

Getting from 48 V to Load Voltage: Improving Low Voltage DC-DC Converter Performance with GaN Transistors

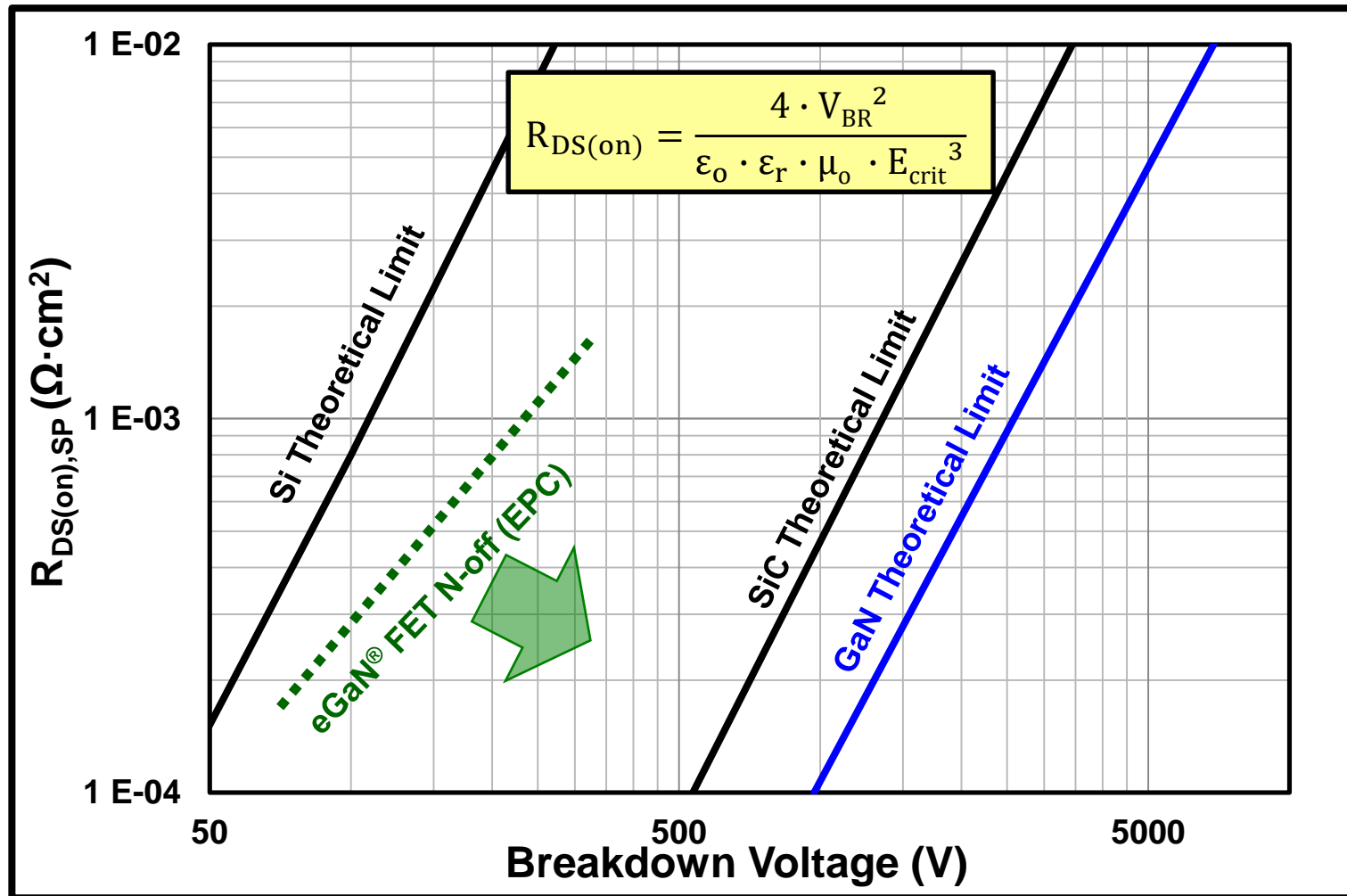
Alex Lidow

David Reusch

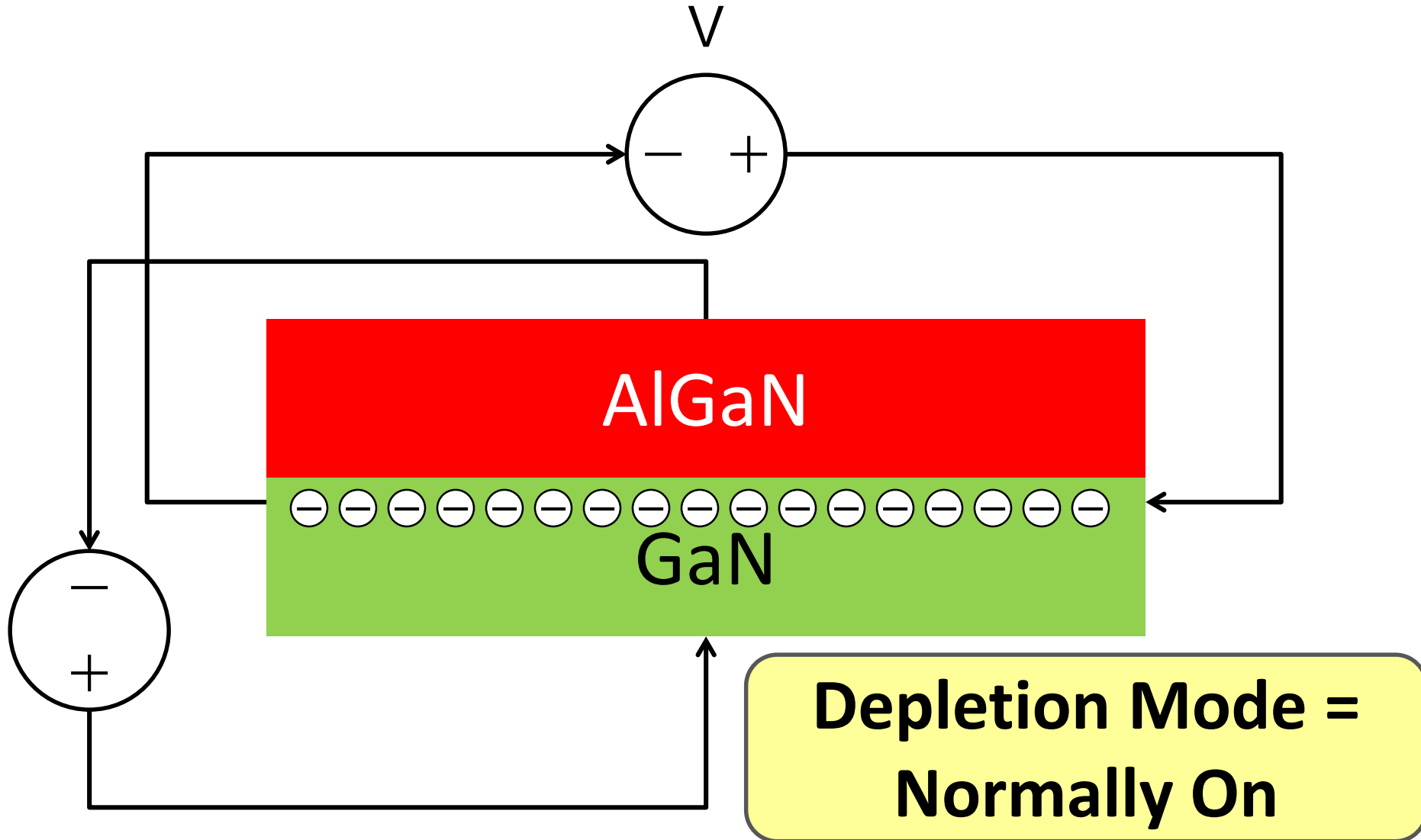
John Glaser

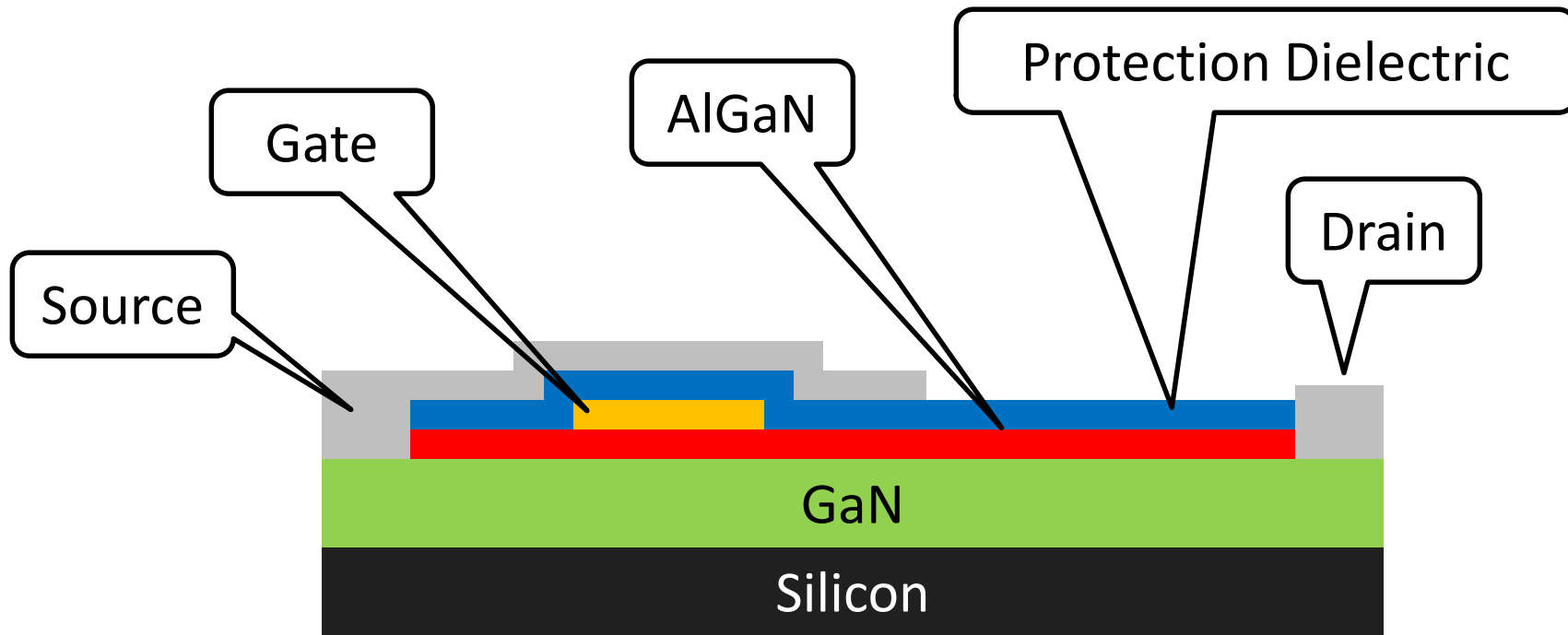
- **State of the Art in GaN**
- **Design Basics**
- **Design Examples**
- **What is in the Future?**

State of the Art

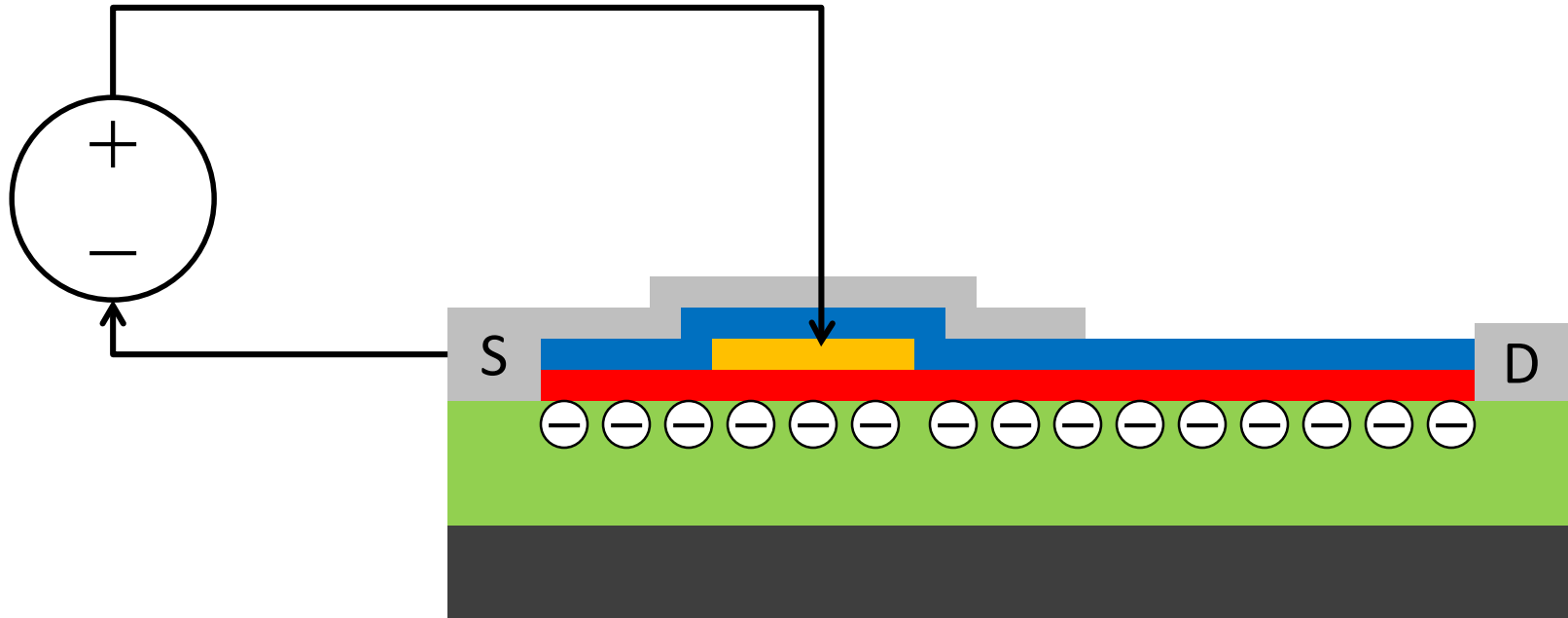


Theoretical Channel Resistance

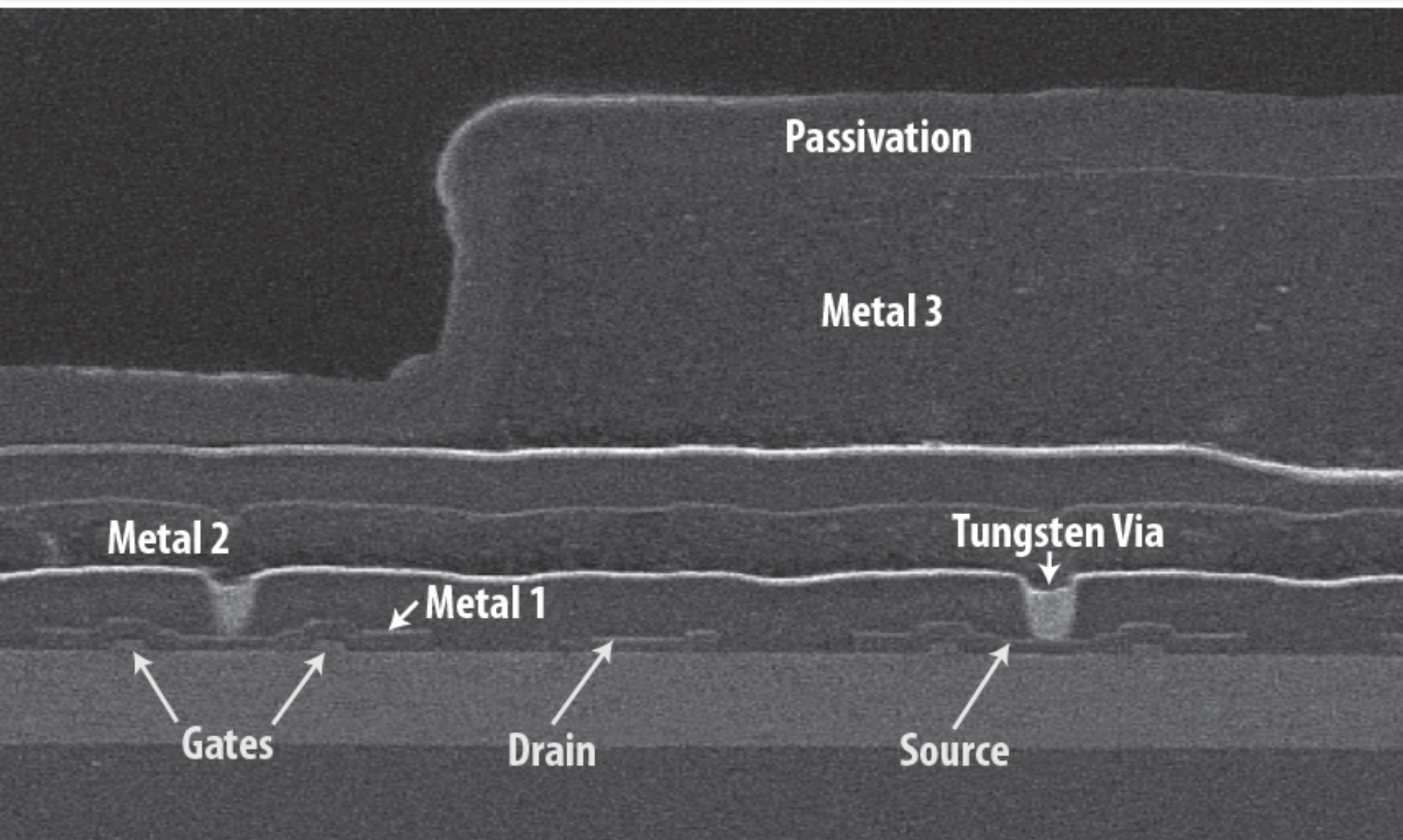




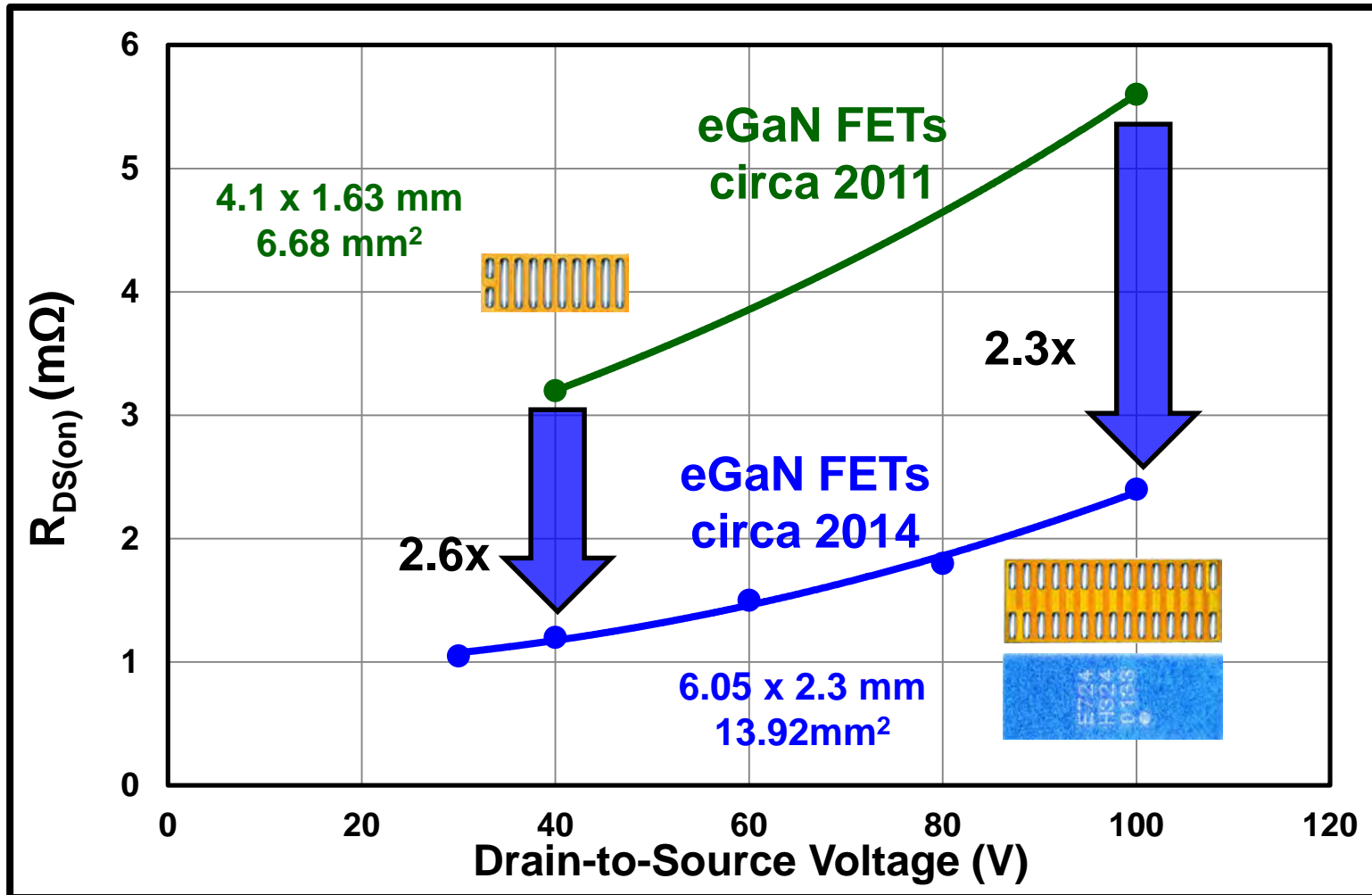
Forms the foundation for a Depletion Mode device



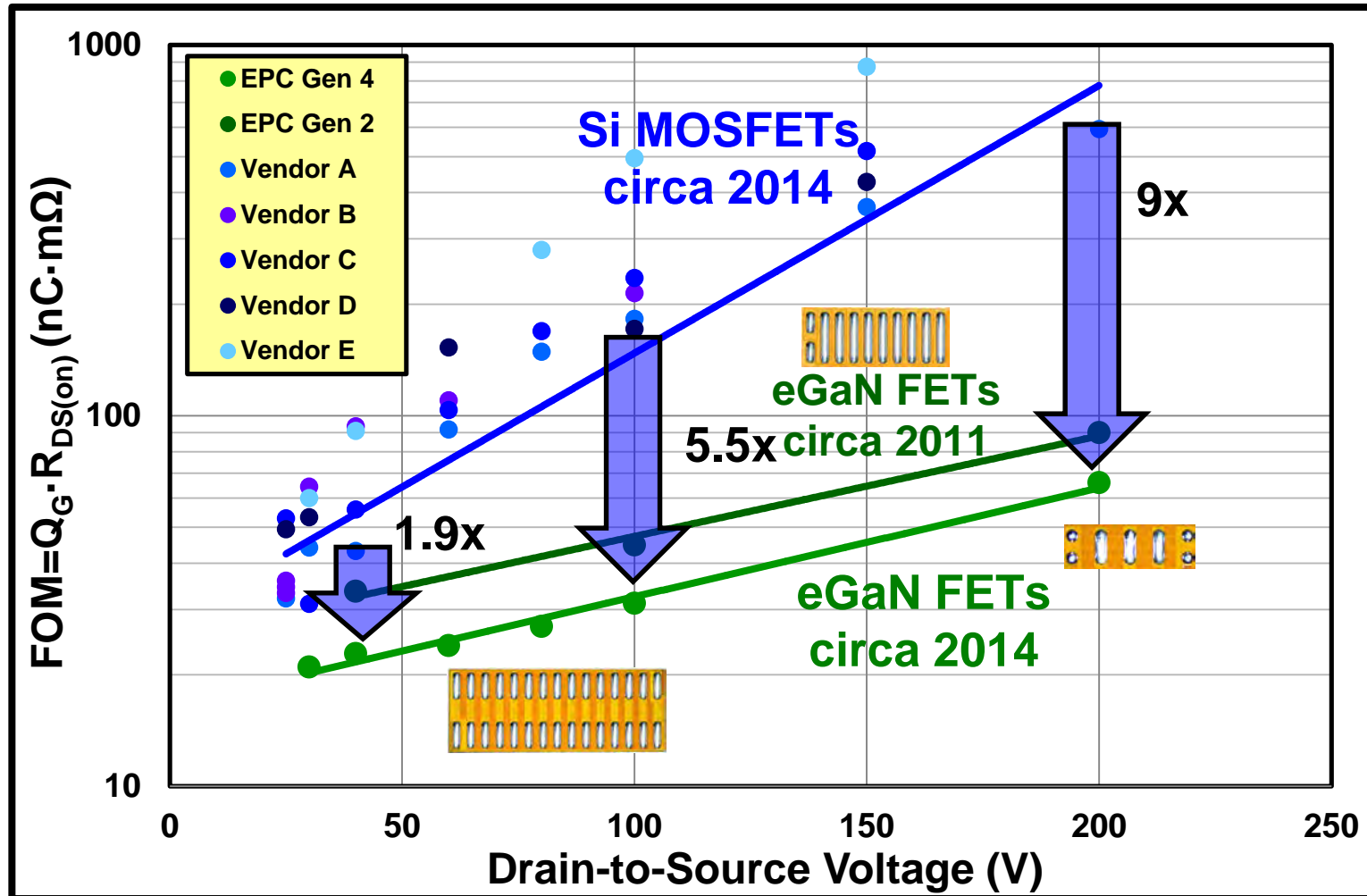
A positive voltage from Gate-To-Source establishes an electron gas under the gate



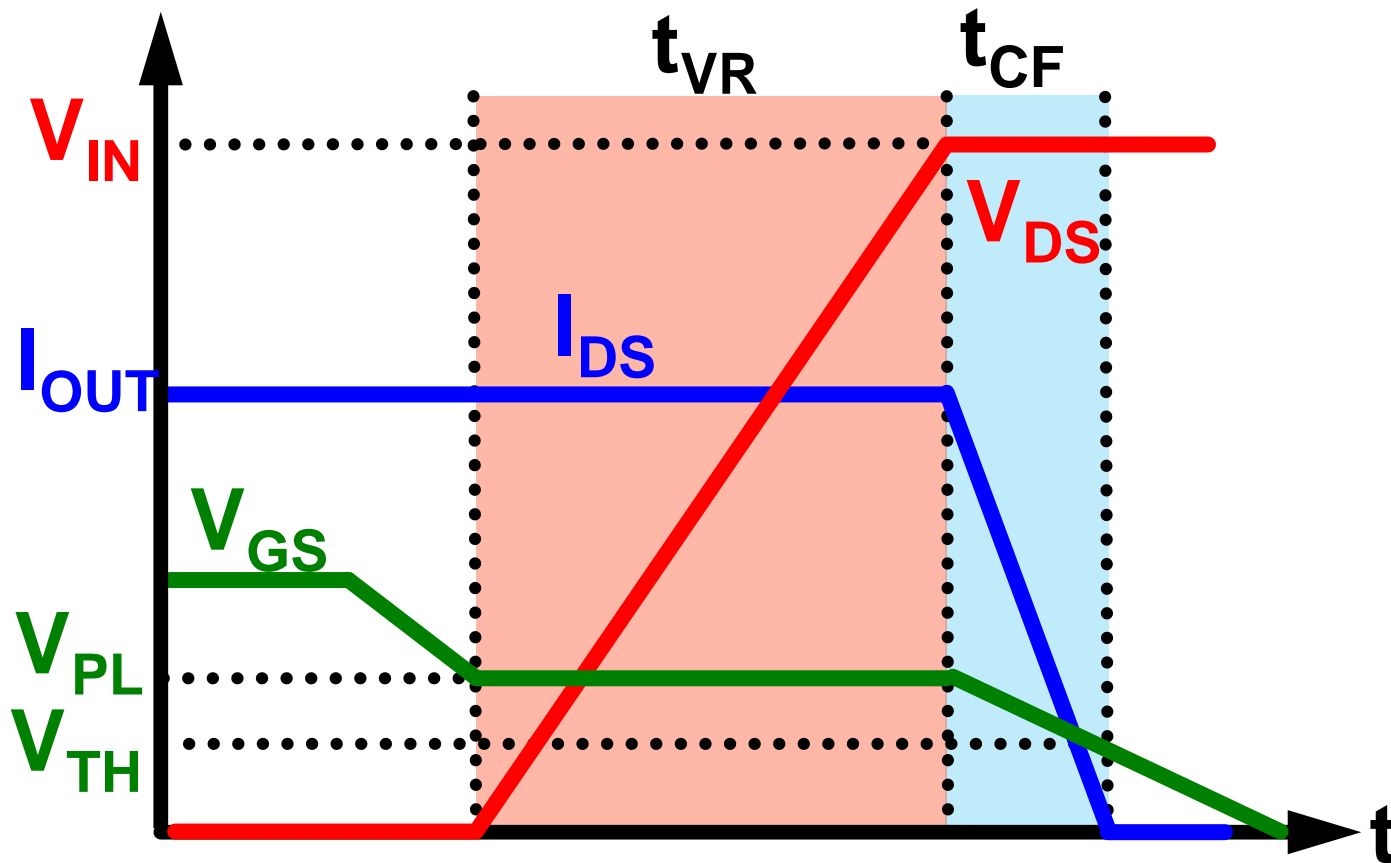
- **Lower On Resistance**
- **Faster**
- **Smaller**
- **Lower Thermal Impedance**
- **Lower Cost**



$V_{GS}=5\text{ V}$

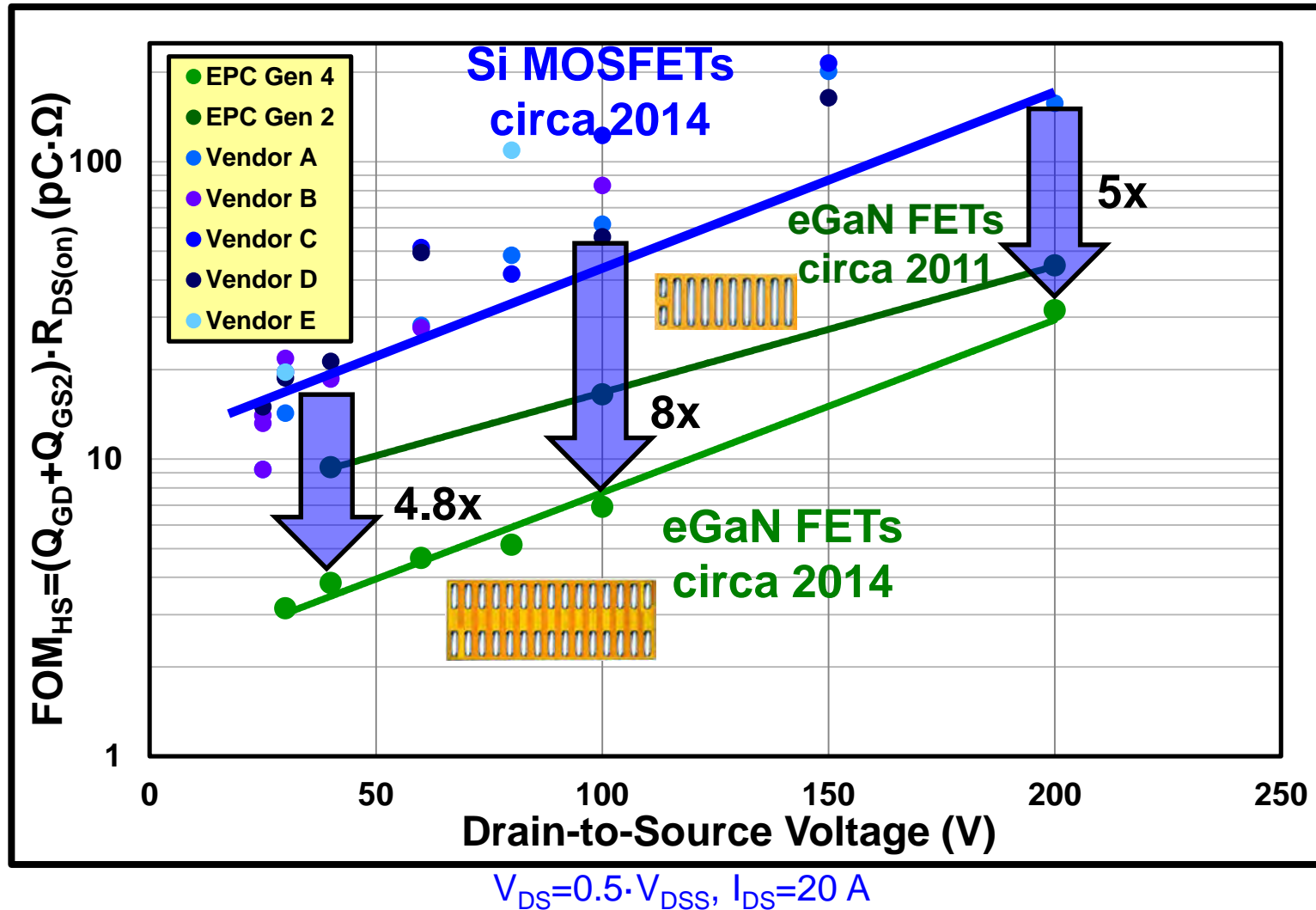


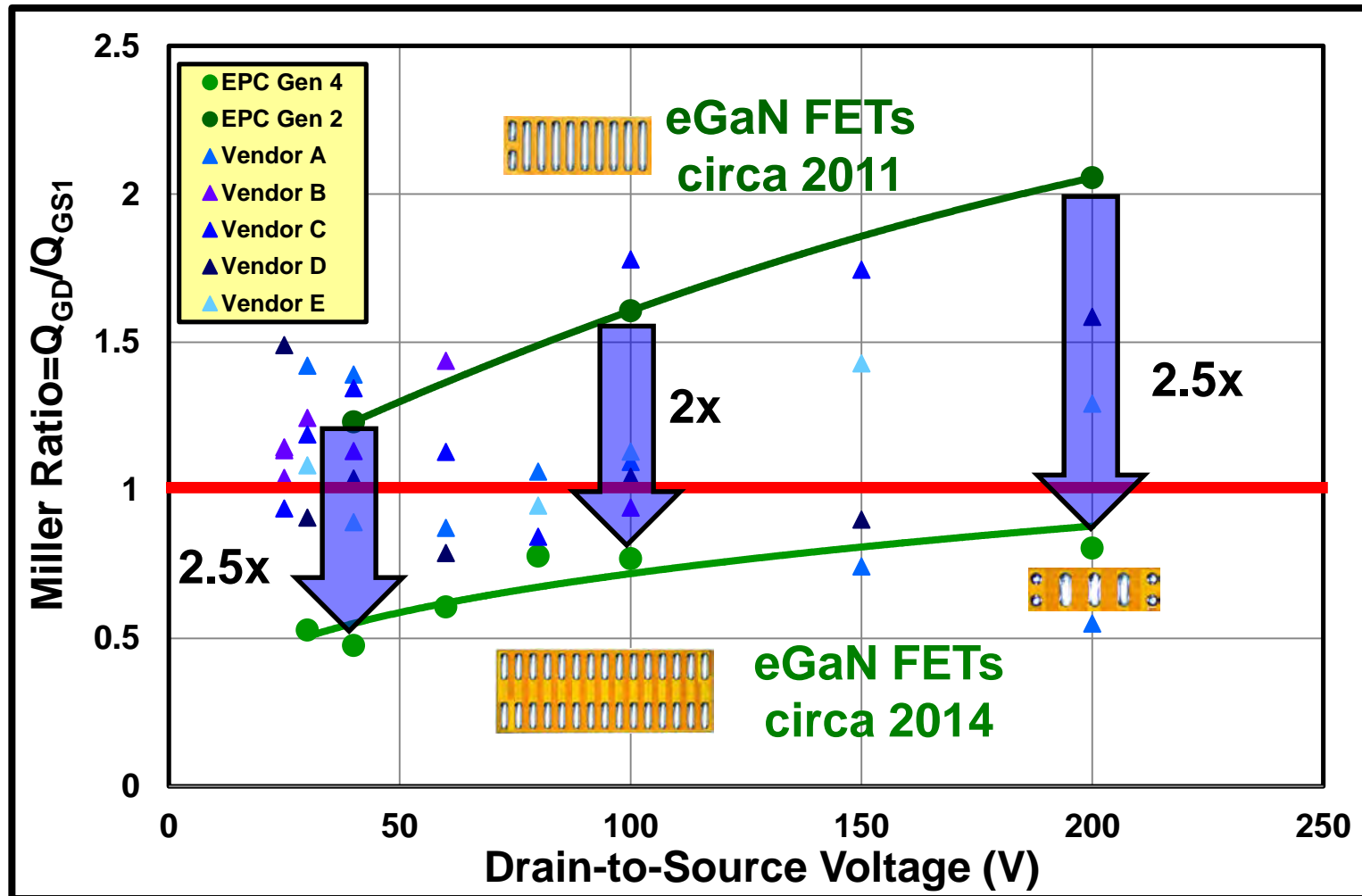
$$V_{DS} = 0.5 \cdot V_{DSS}$$



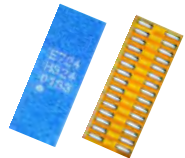
$$P_{t_{VR}} \approx \frac{V_{IN} \cdot I_{OUT} \cdot Q_{GD}}{2 \cdot I_G}$$

$$P_{t_{CF}} \approx \frac{V_{IN} \cdot I_{OUT} \cdot Q_{GS2}}{2 \cdot I_G}$$





$V_{DS} = 0.5 \cdot V_{DSS}, I_{DS} = 20 \text{ A}$

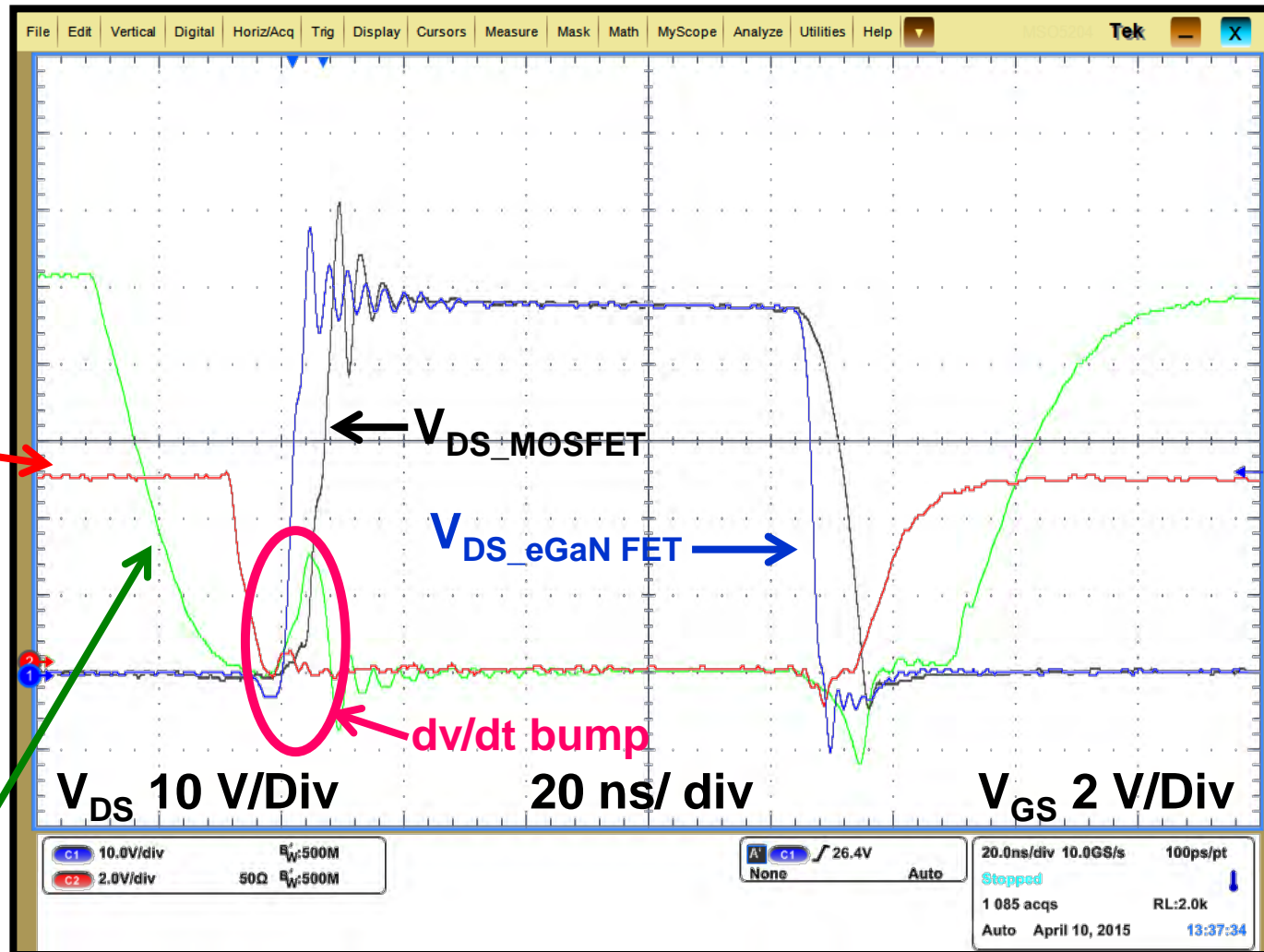


80 V eGaN FET
1.8 mΩ
13.9 mm²

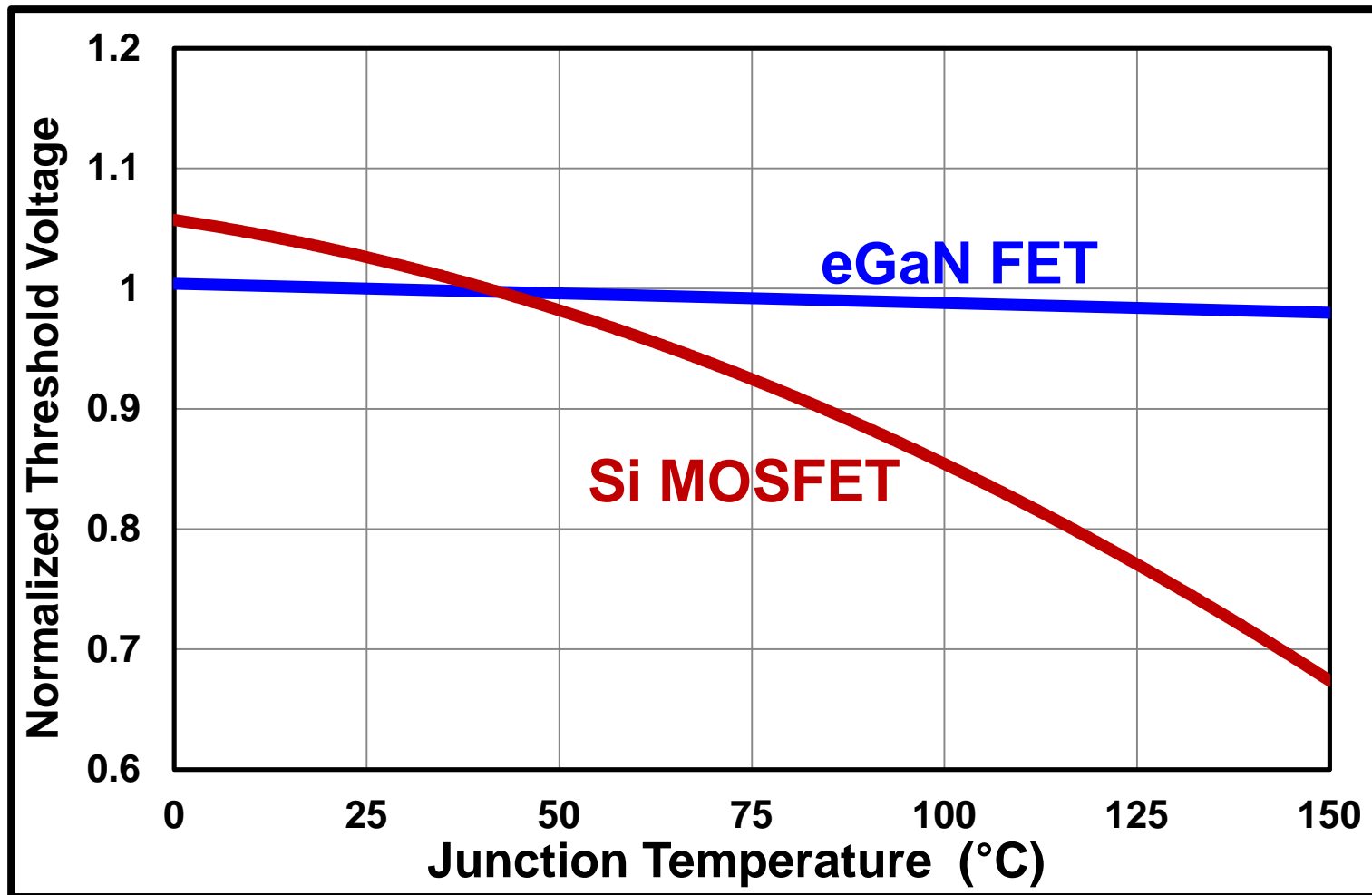
$V_{DS_eGaN\ FET}$
 $V_{GS_eGaN\ FET}$

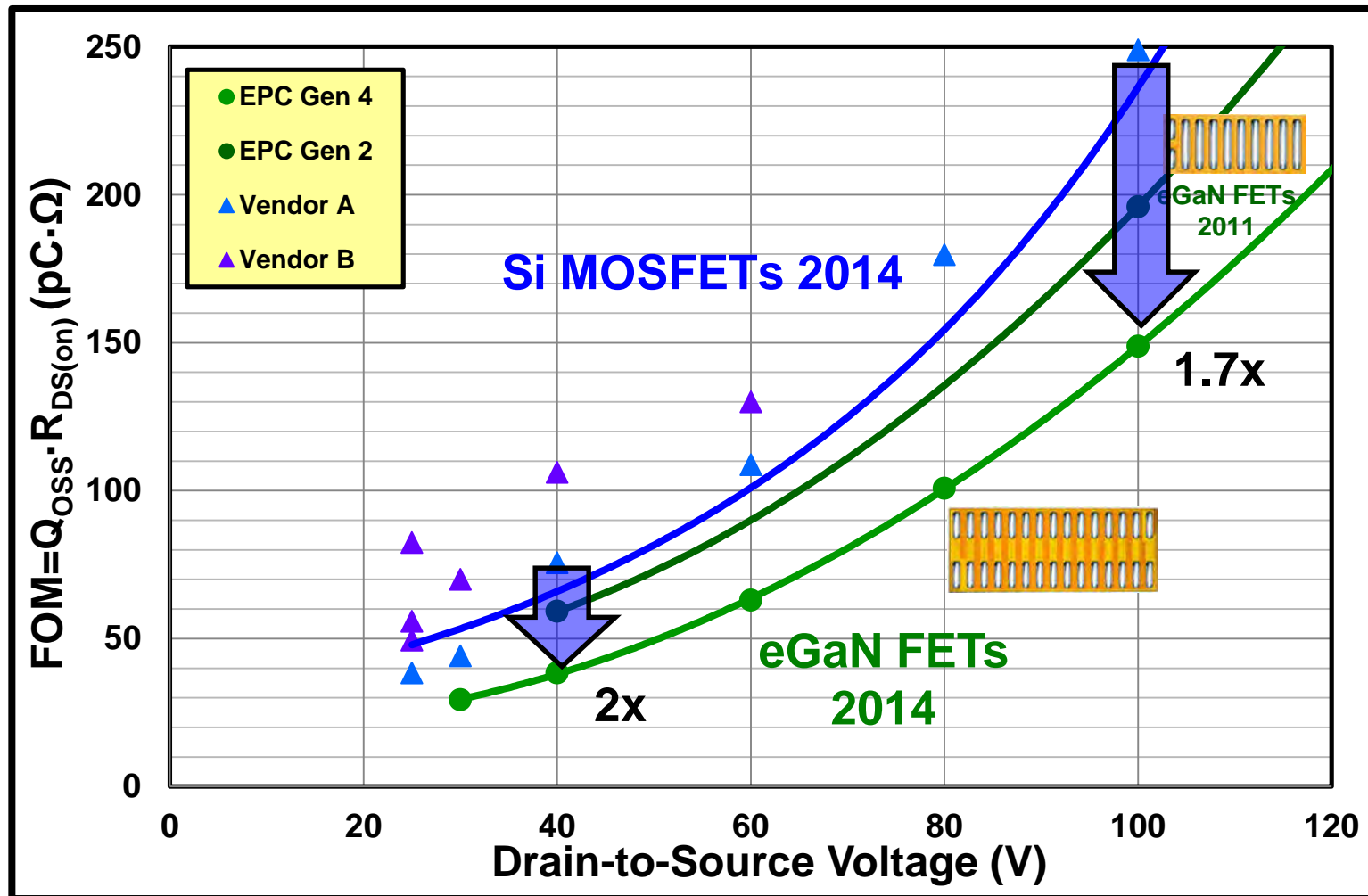
80 V Si MOSFET
3.7 mΩ
31 mm²

V_{GS_MOSFET}
 V_{DS_MOSFET}

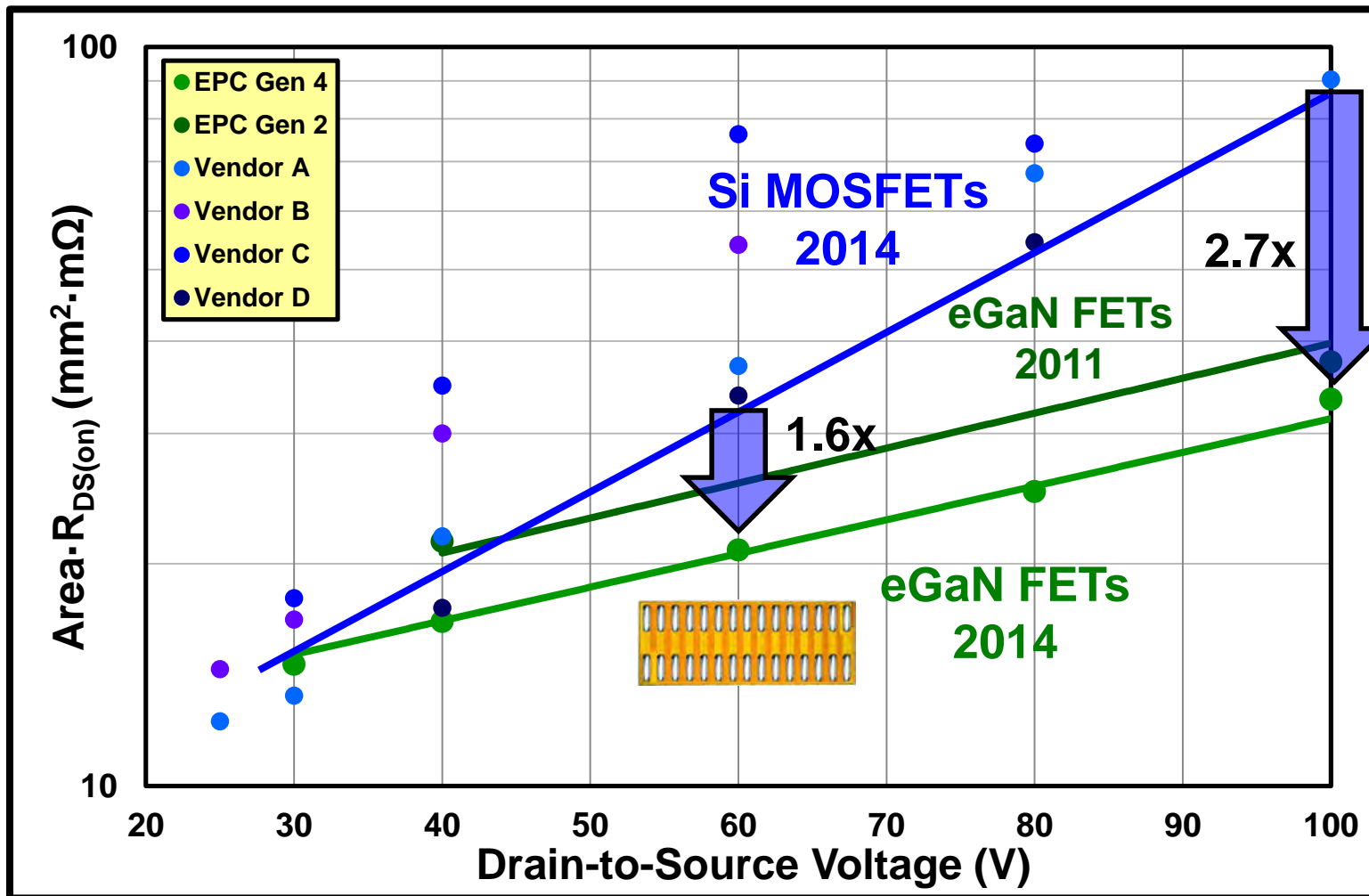


$V_{IN}=48\ V\ V_{OUT}=1\ V\ I_{OUT}=30\ A$

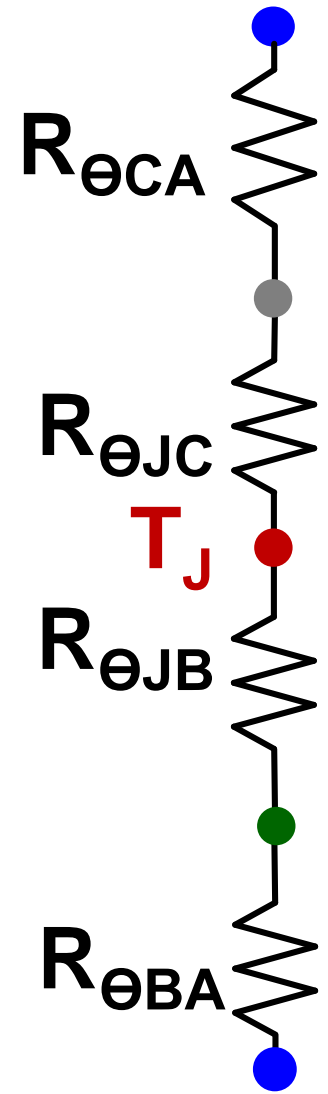
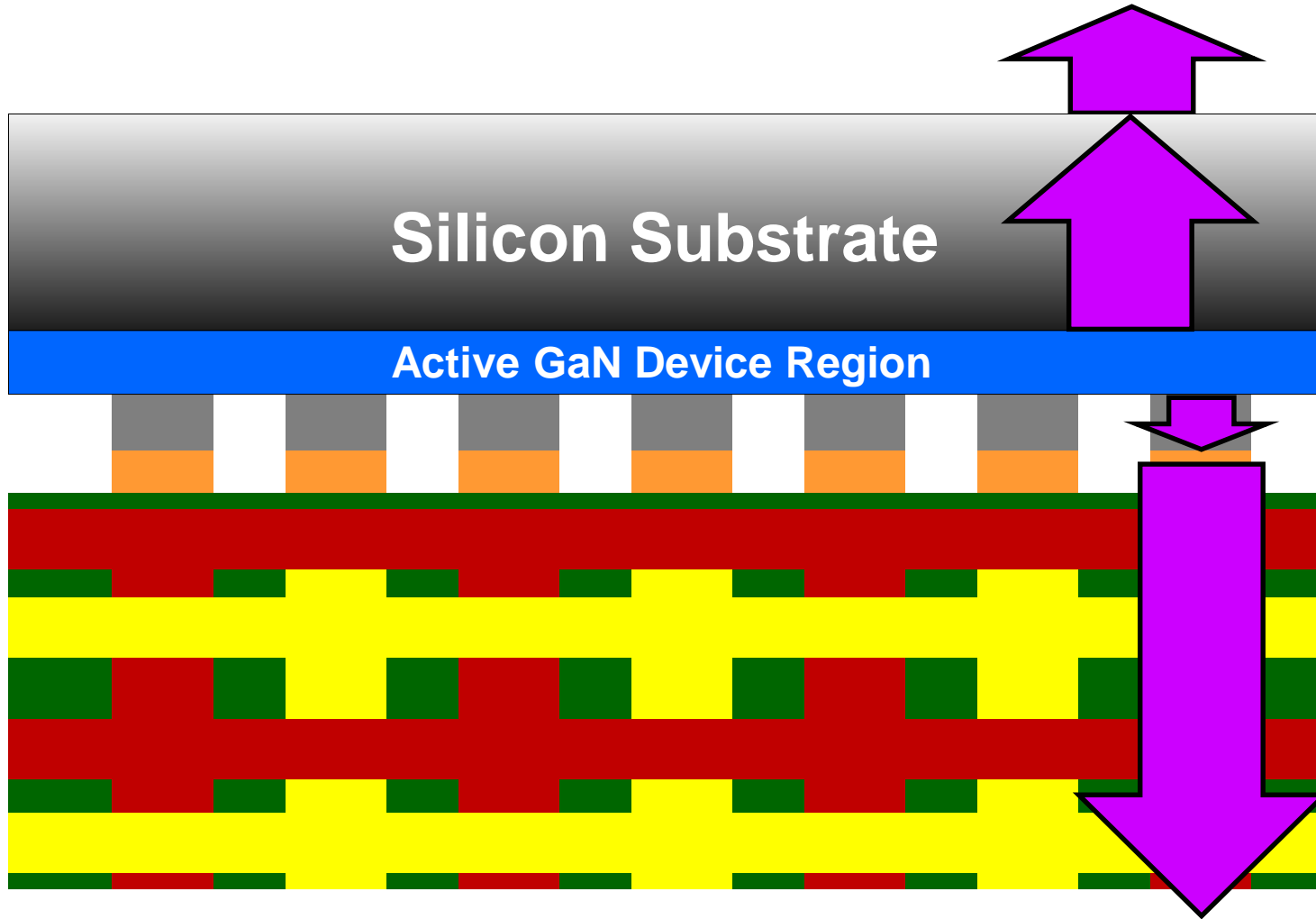


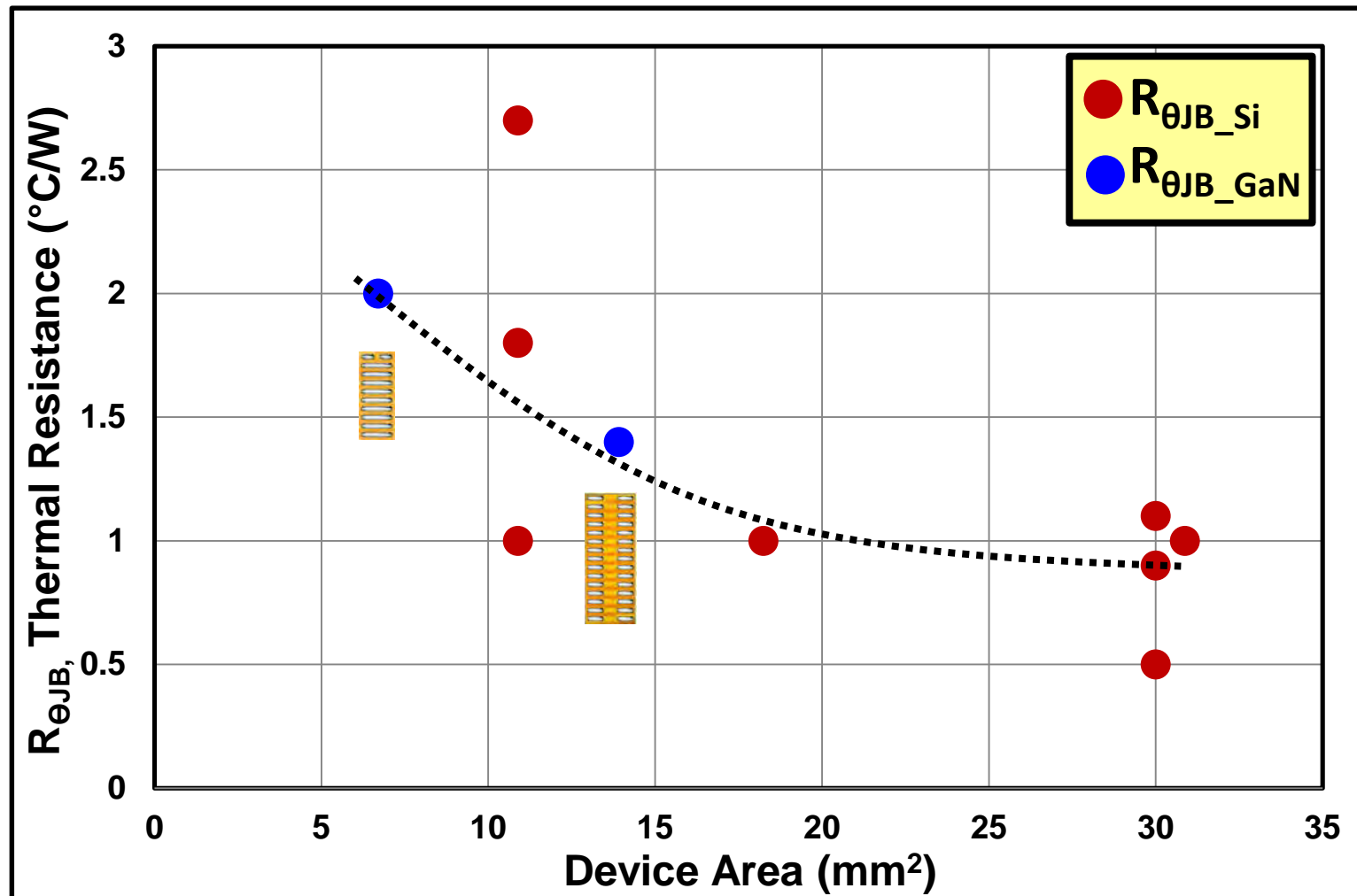


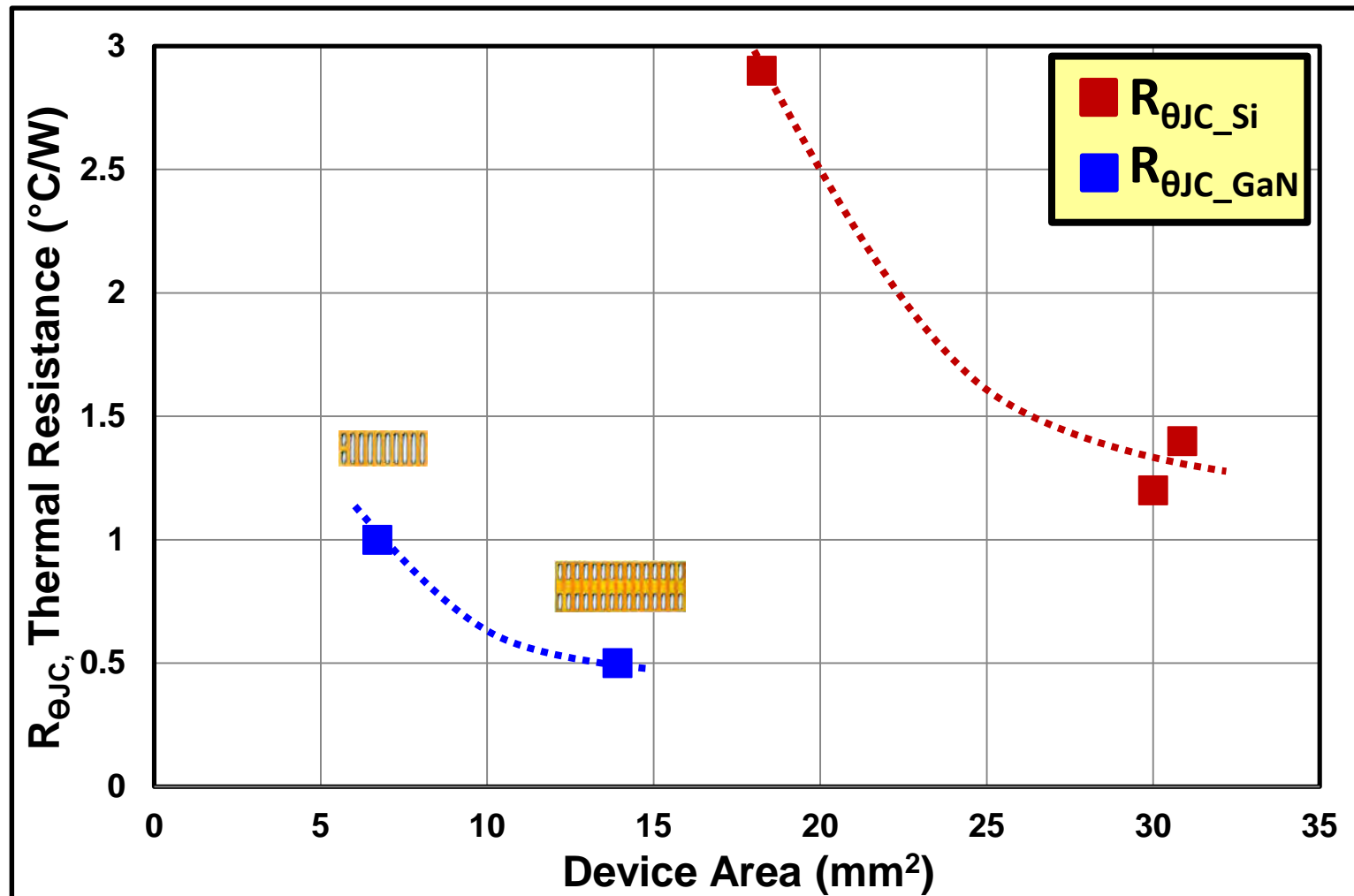
$$V_{DS} = 0.5 \cdot V_{DSS}$$



Actual Product Resistance







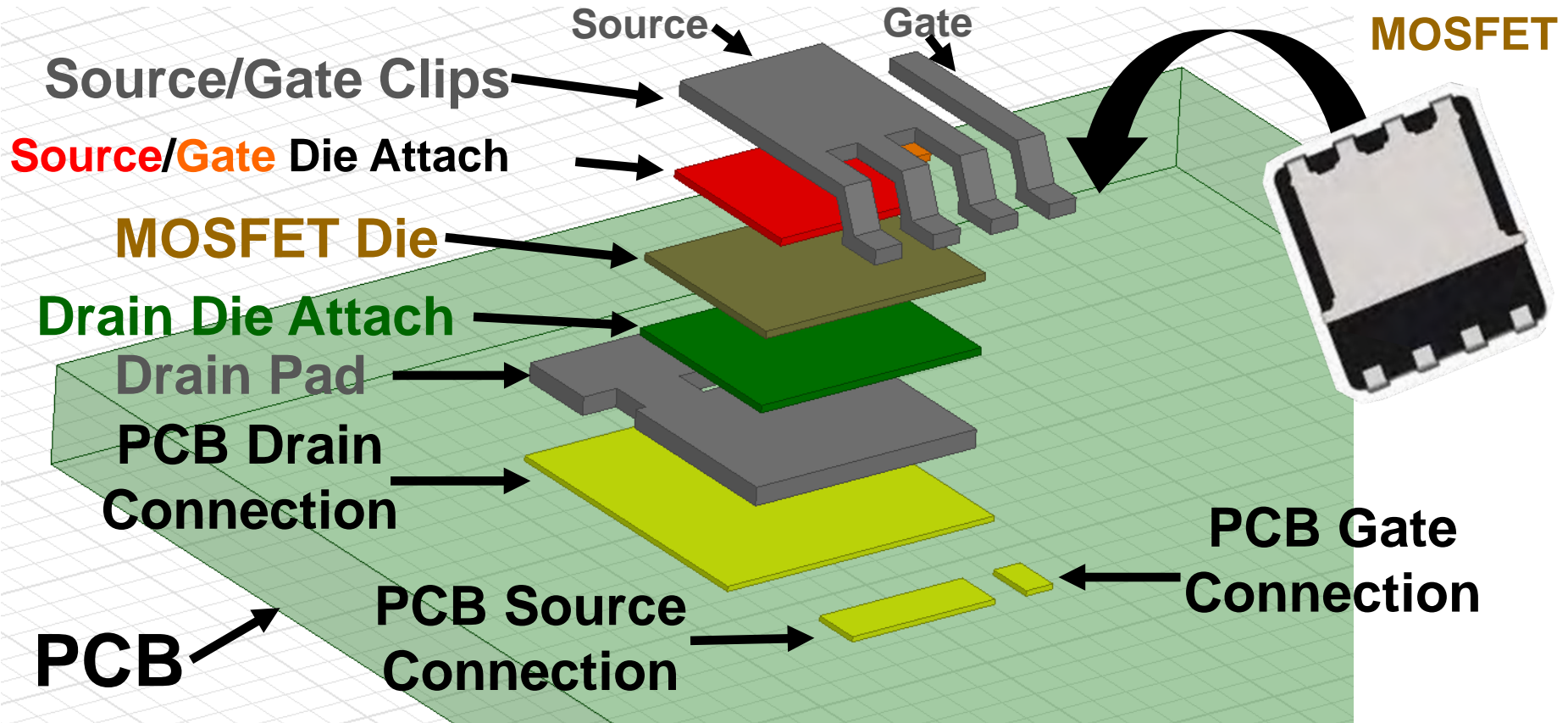
	2010	2016
Starting Material	lower	lower
Epi Growth	<i>~higher</i>	<i>~same?</i>
Wafer Fab	lower	lower
Test	same	same
Assembly	lower	lower
OVERALL	<i>~higher</i>	<i>lower!</i>

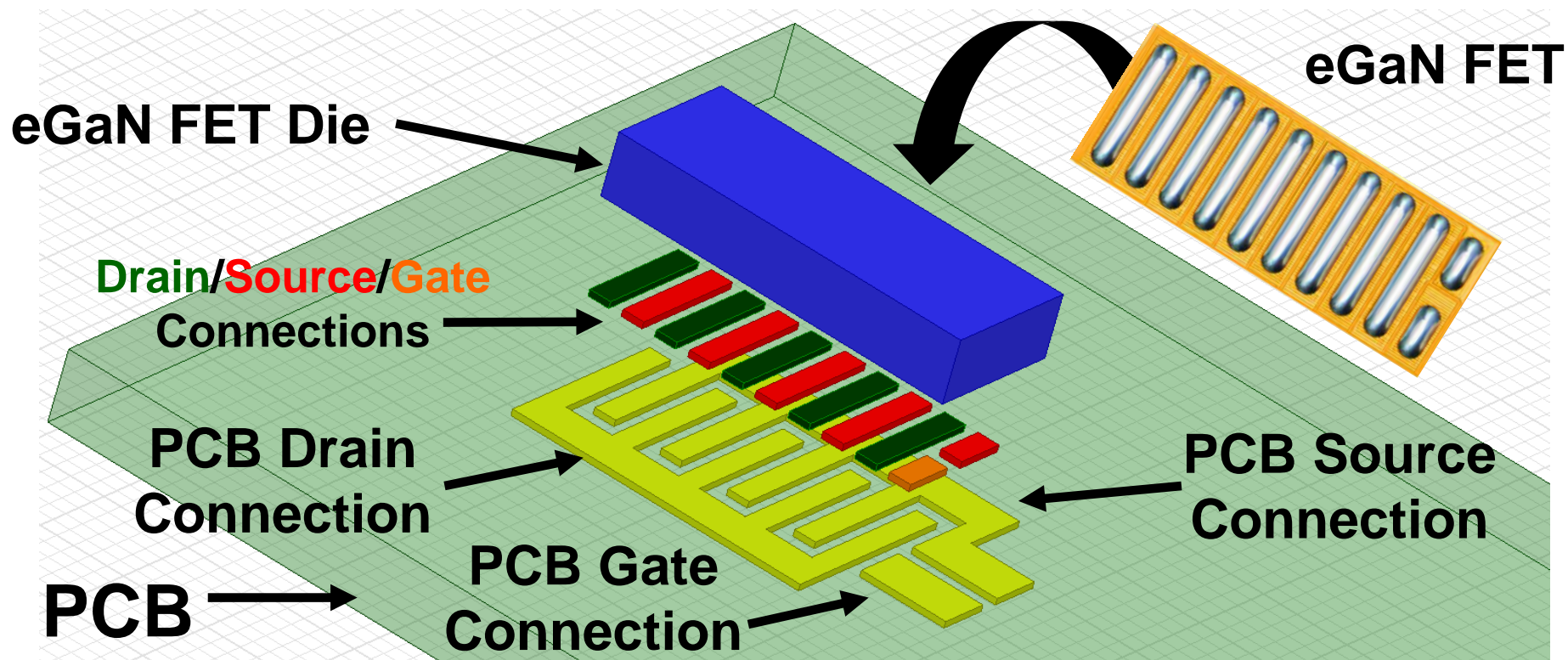
* Product with the same on resistance and voltage rating

Active die $<3 \text{ mm}^2$

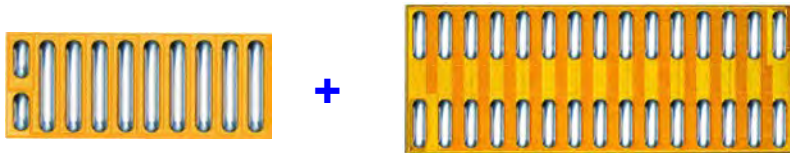
	2014	2016
Starting Material	lower	lower
Epi Growth	<i>~same</i>	<i>~same?</i>
Wafer Fab	lower	lower
Test	same	same
Assembly	lower	lower
OVERALL	<i>lower!</i>	<i>lower!</i>

* Product with the same on resistance and voltage rating



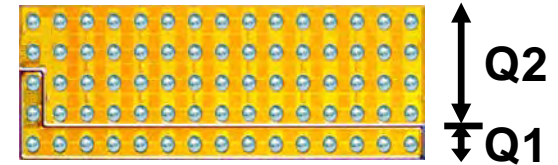


Generation 2/4 Discrete HB

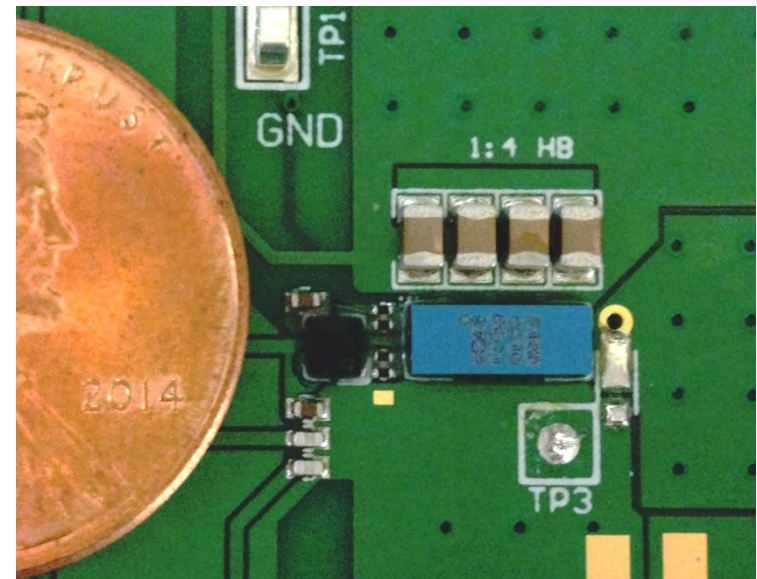
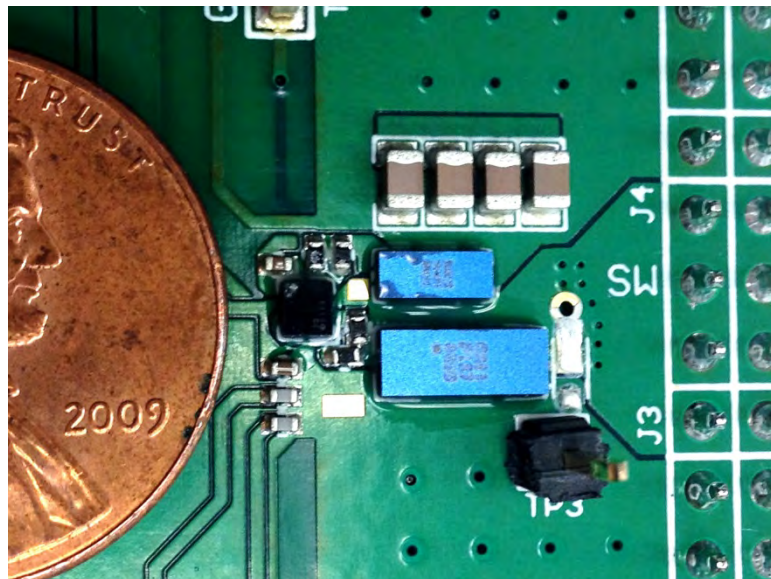


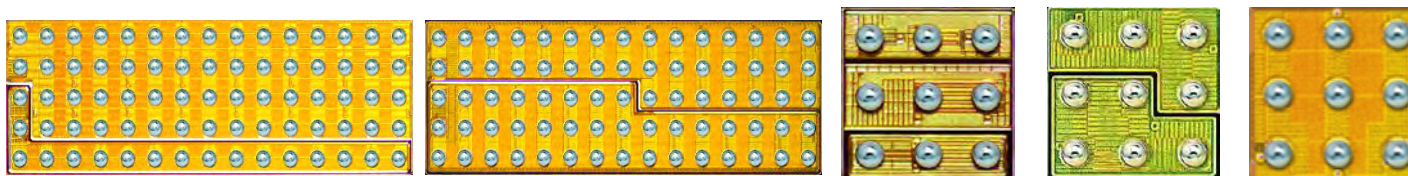
Top Switch (Q1) Bottom Switch (Q2)

Generation 4 Monolithic 1:4 HB



33 % die size reduction

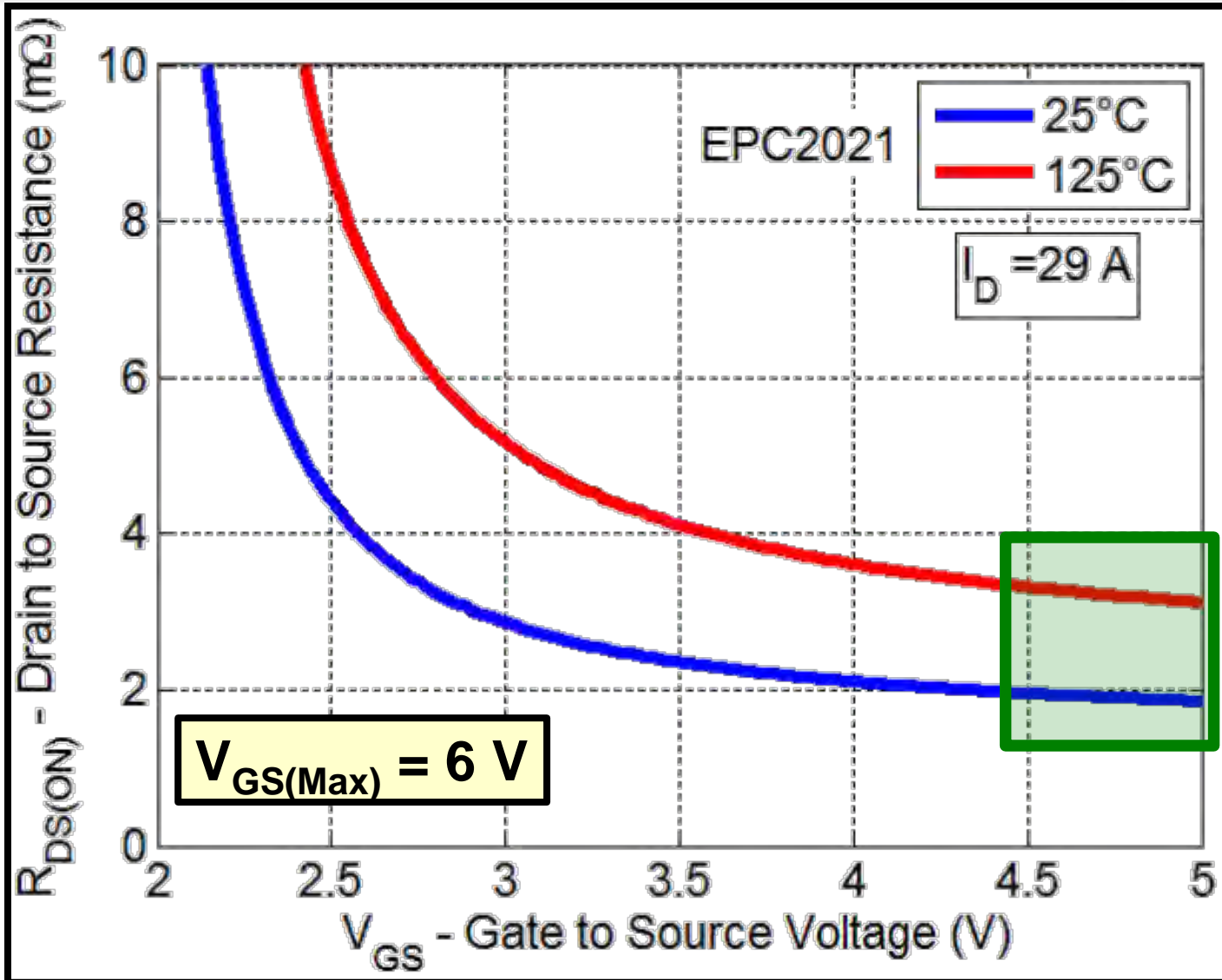




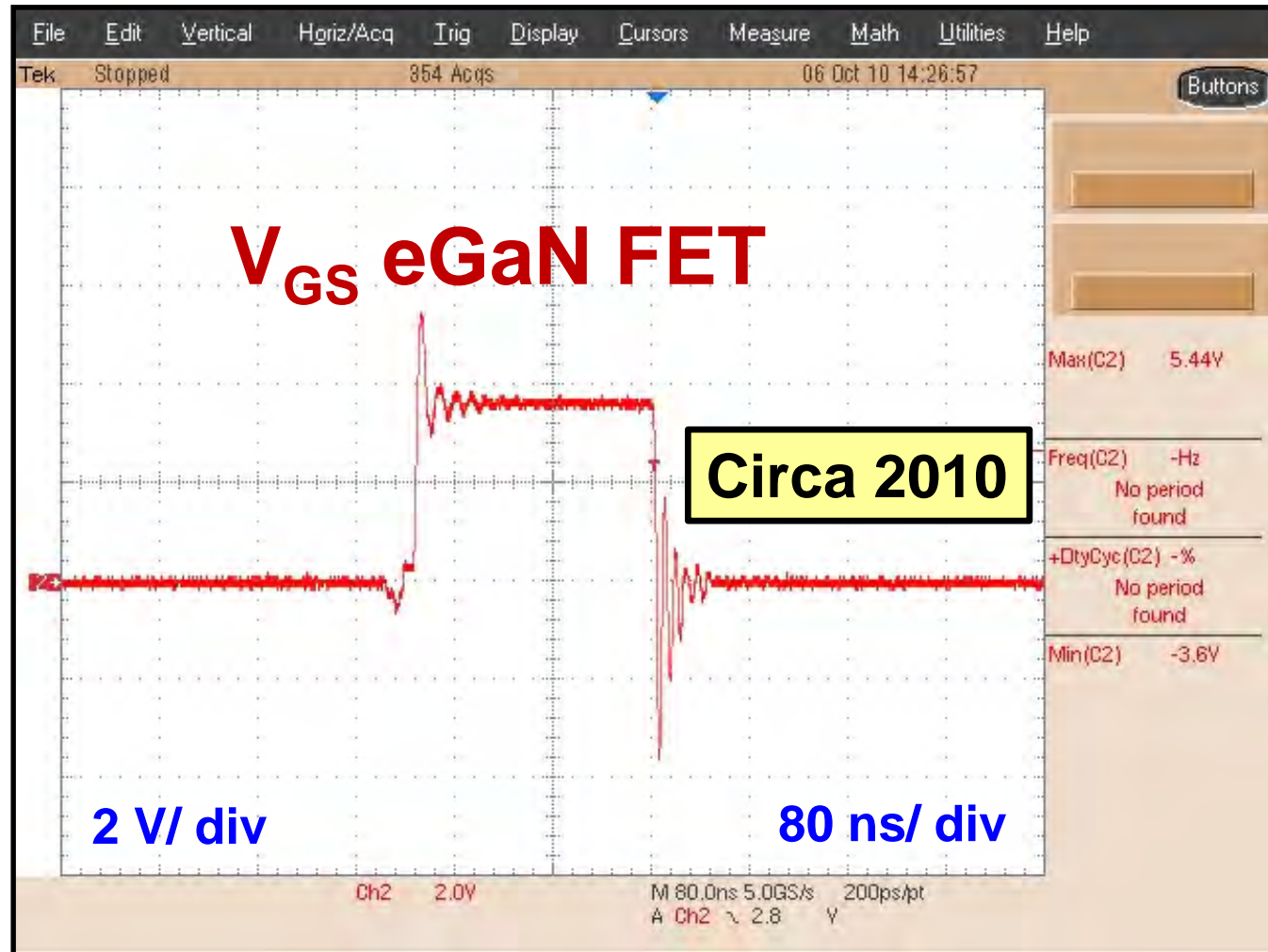
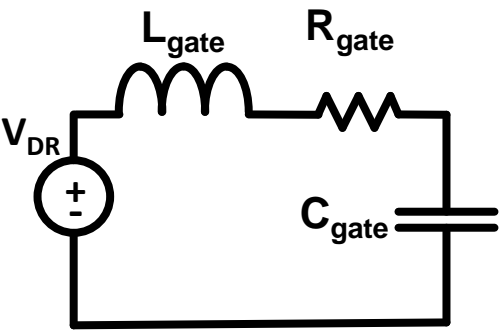
Part Number	Configuration	V_{DS}	Max $R_{DS(ON)}$ ($m\Omega$) @ $5V_{GS}$	Q_G typ (nC)	Q_{GS} typ (nC)	Q_{GD} typ (nC)	Q_{OSS} typ (nC)	Q_{RR} (nC)	Pulsed I_D (A)
EPC2100	Dual Asymmetric	30	8 2	3.5 15	1.4 4.6	0.57 2.6	5.5 28	0	100 400
EPC2101	Dual Asymmetric	60	11.5 2.7	2.7 12	1 3.7	0.50 2.5	9 45	0	80 350
EPC2102	Dual	60	4.4	6.8	2.3	1.4	23 31	0	215
EPC2108	Dual with Bootstrap	60	190	0.22	0.085	0.045	0.65 1	0	5.5
EPC2105	Dual Asymmetric	80	14.5 3.5	2.5 10	1 3.2	0.50 2	11 55	0	75 320
EPC2103	Dual	80	5.5	6.5	2.0	1.3	29 39	0	195
EPC2104	Dual	100	6.3	7	2.0	1.2	35 47	0	165
EPC2106	Dual	100	70	0.73 0.76	0.22 0.24	0.165	3.4 4.4	0	18
EPC2107	Dual with Bootstrap	100	320	0.16	0.065	0.04	0.8 1.4	0	3.8
EPC2110	Dual, Common Source	120	60	0.8	0.25	0.19	4.9	0	20

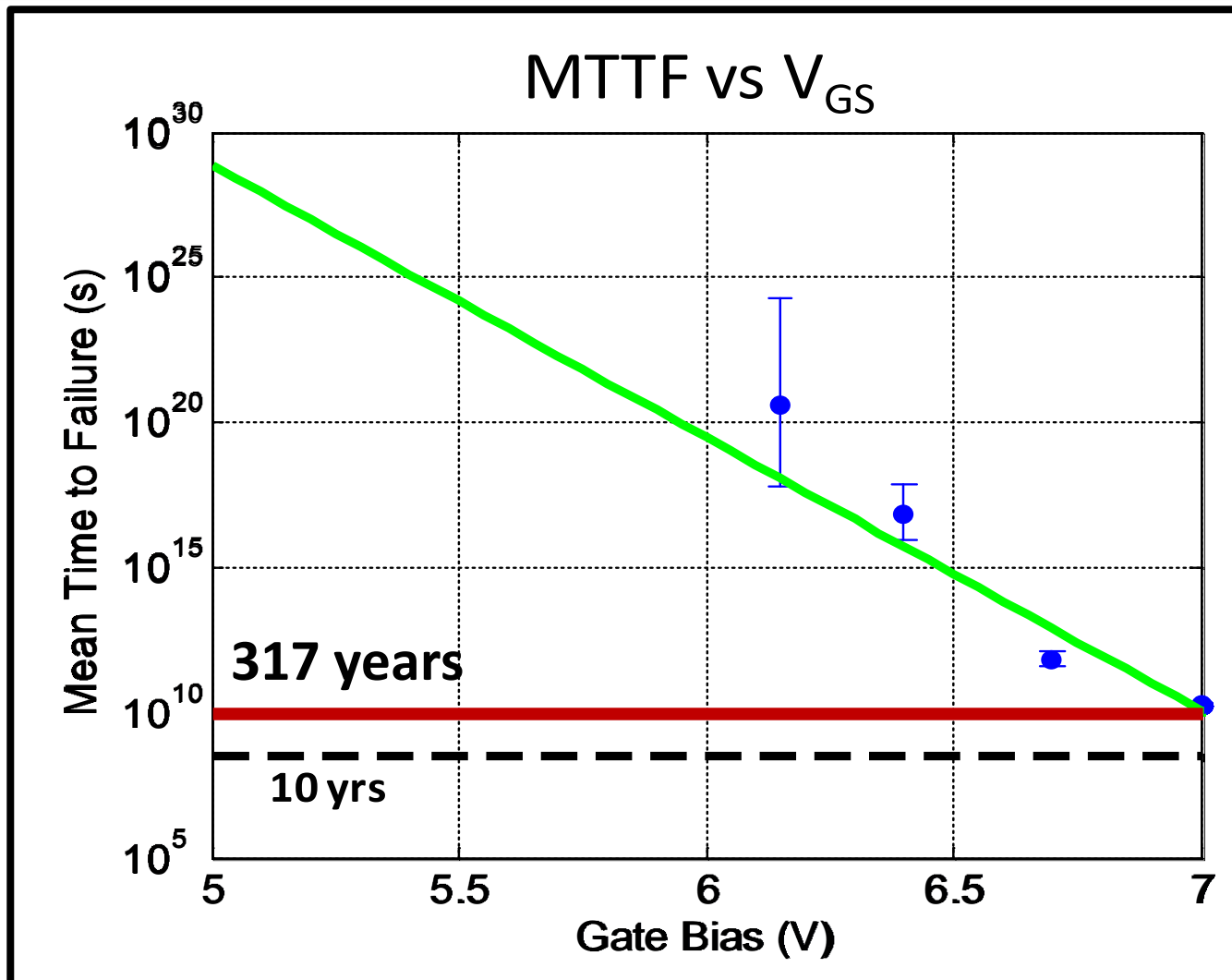
Design Basics

Gate Drive

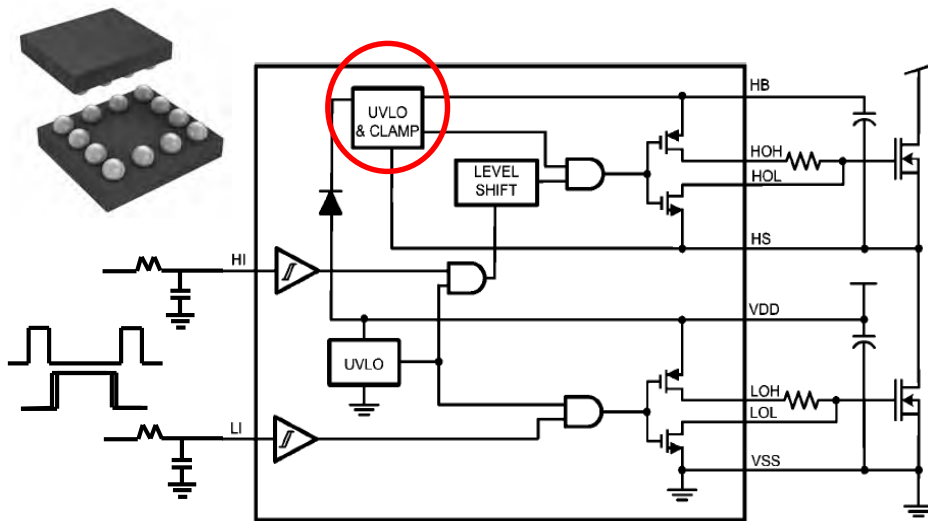


2010 GaN Board #1

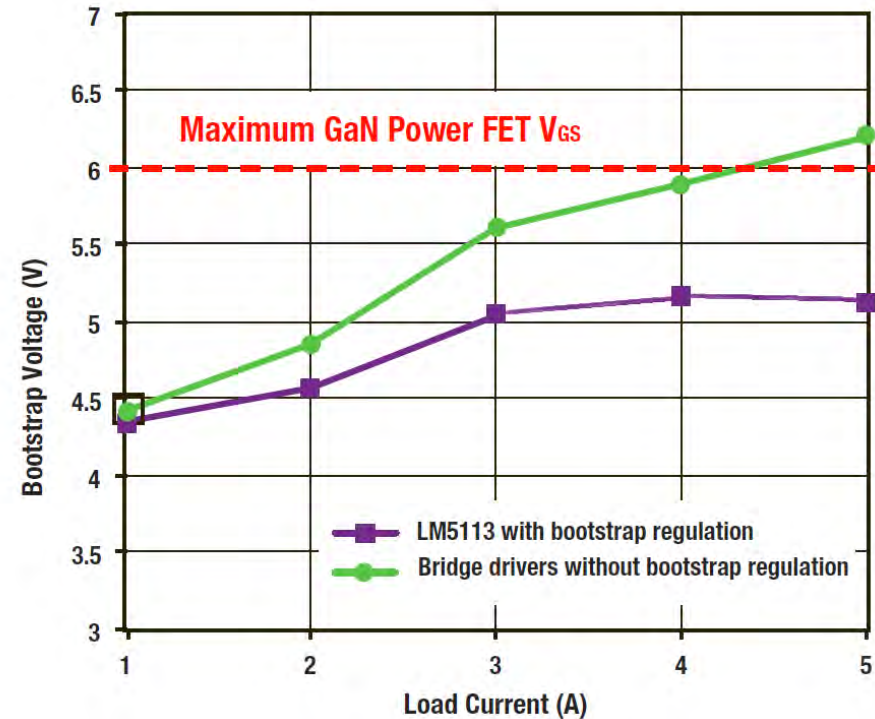




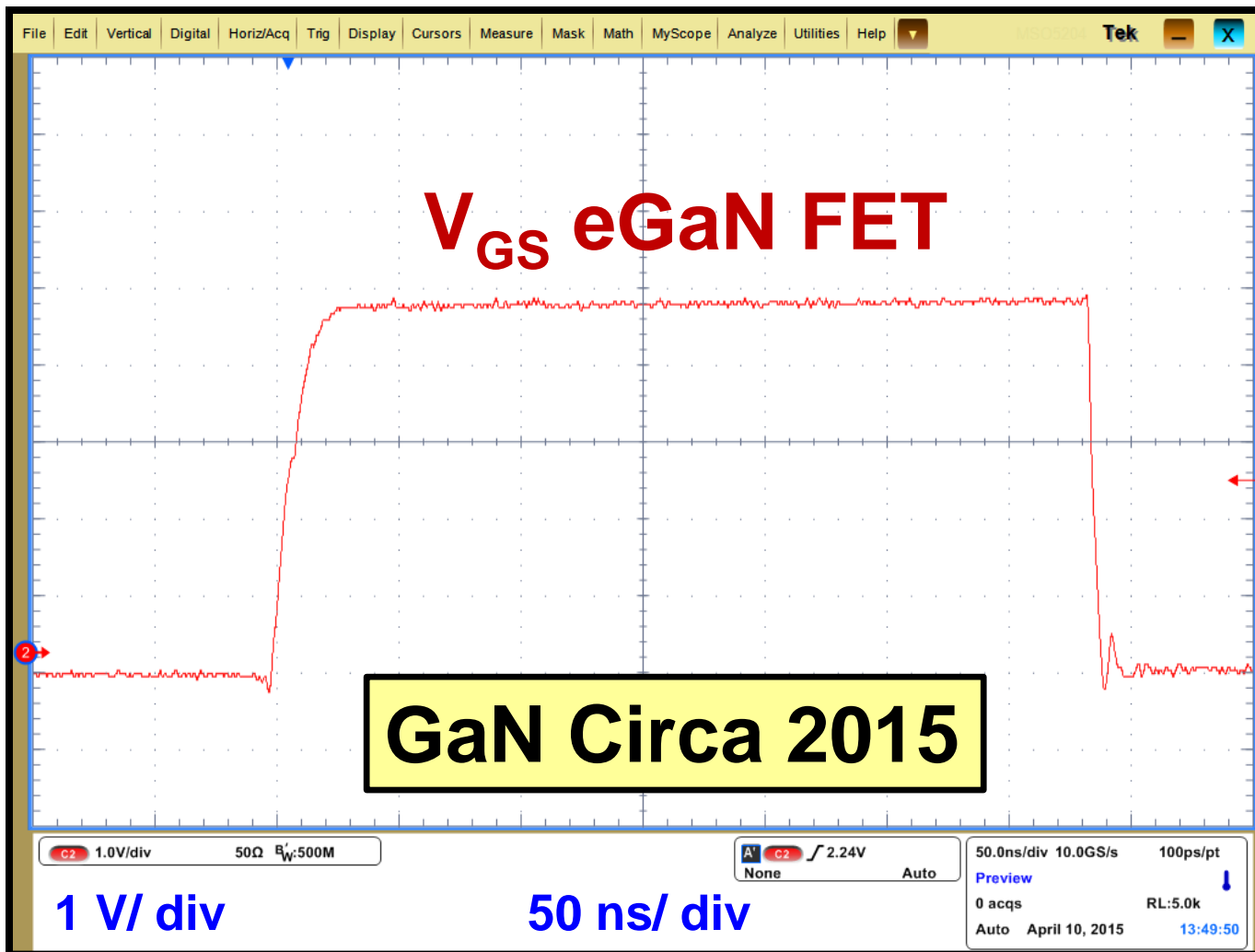
Reference: R. Strittmatter, C. Zhou, A. Lidow, and Y. Ma, "Enhancement Mode Gallium Nitride Transistor Reliability," APEC 2015



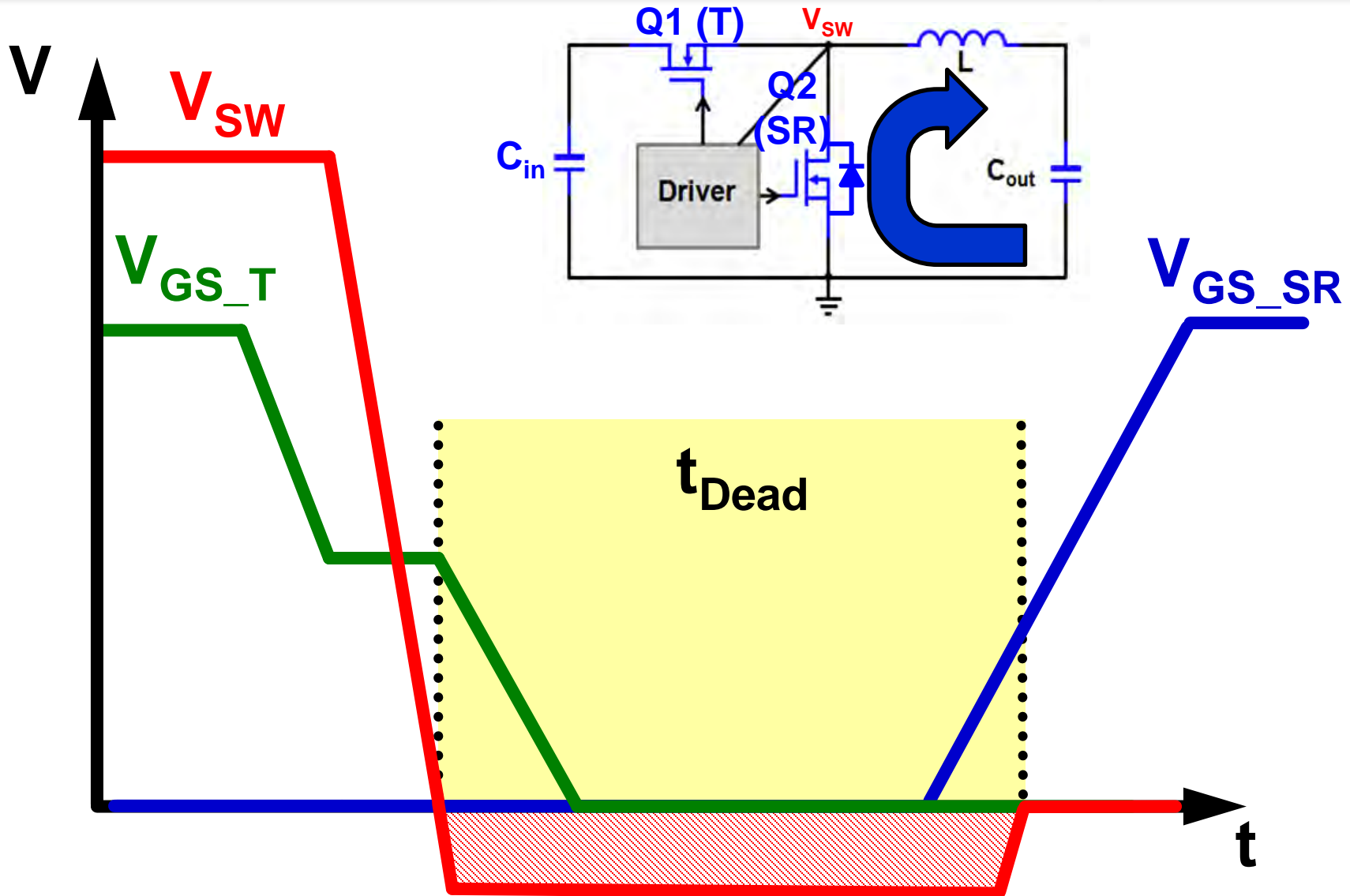
- Bootstrap clamp limits (HS) supply

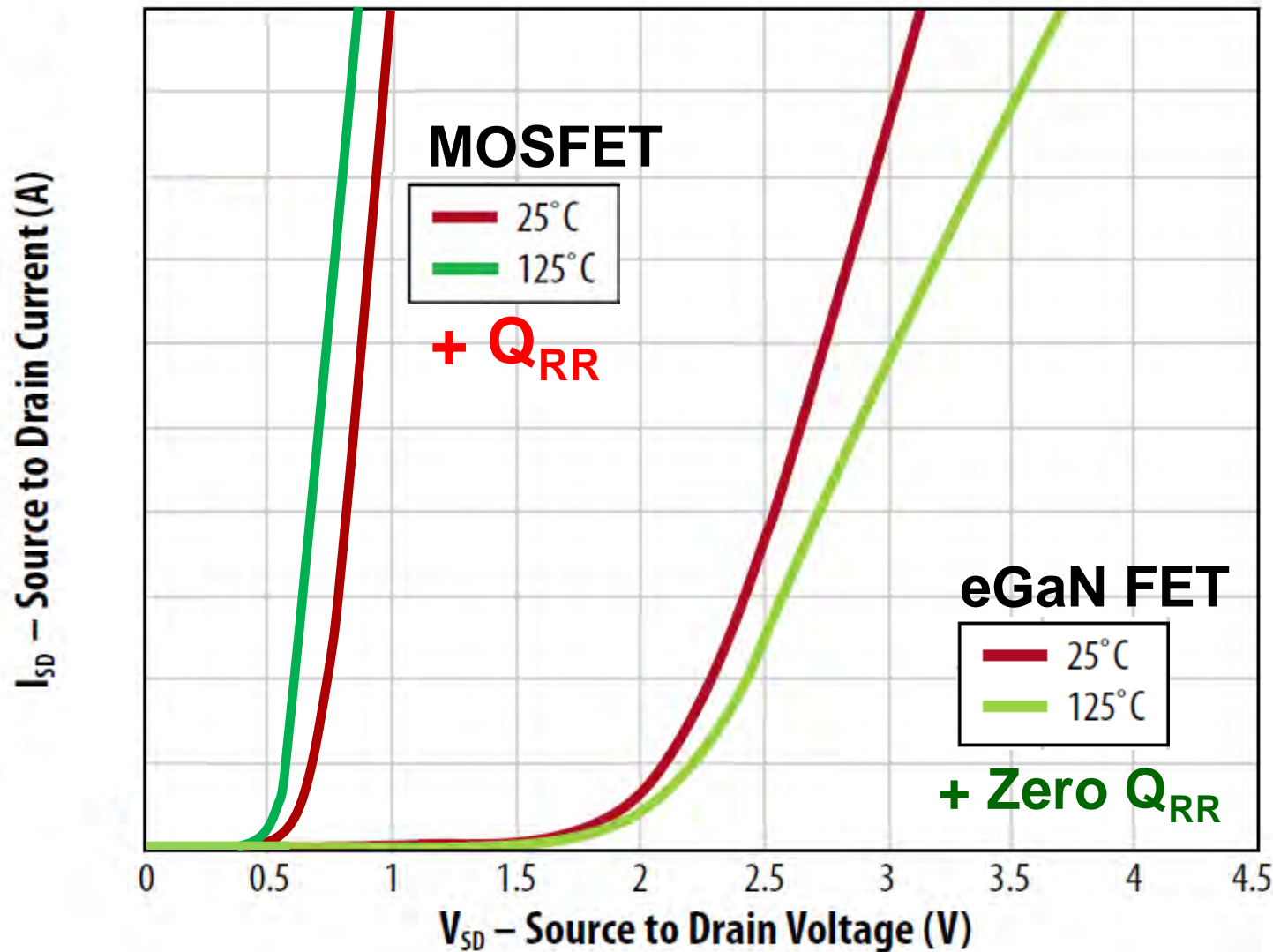


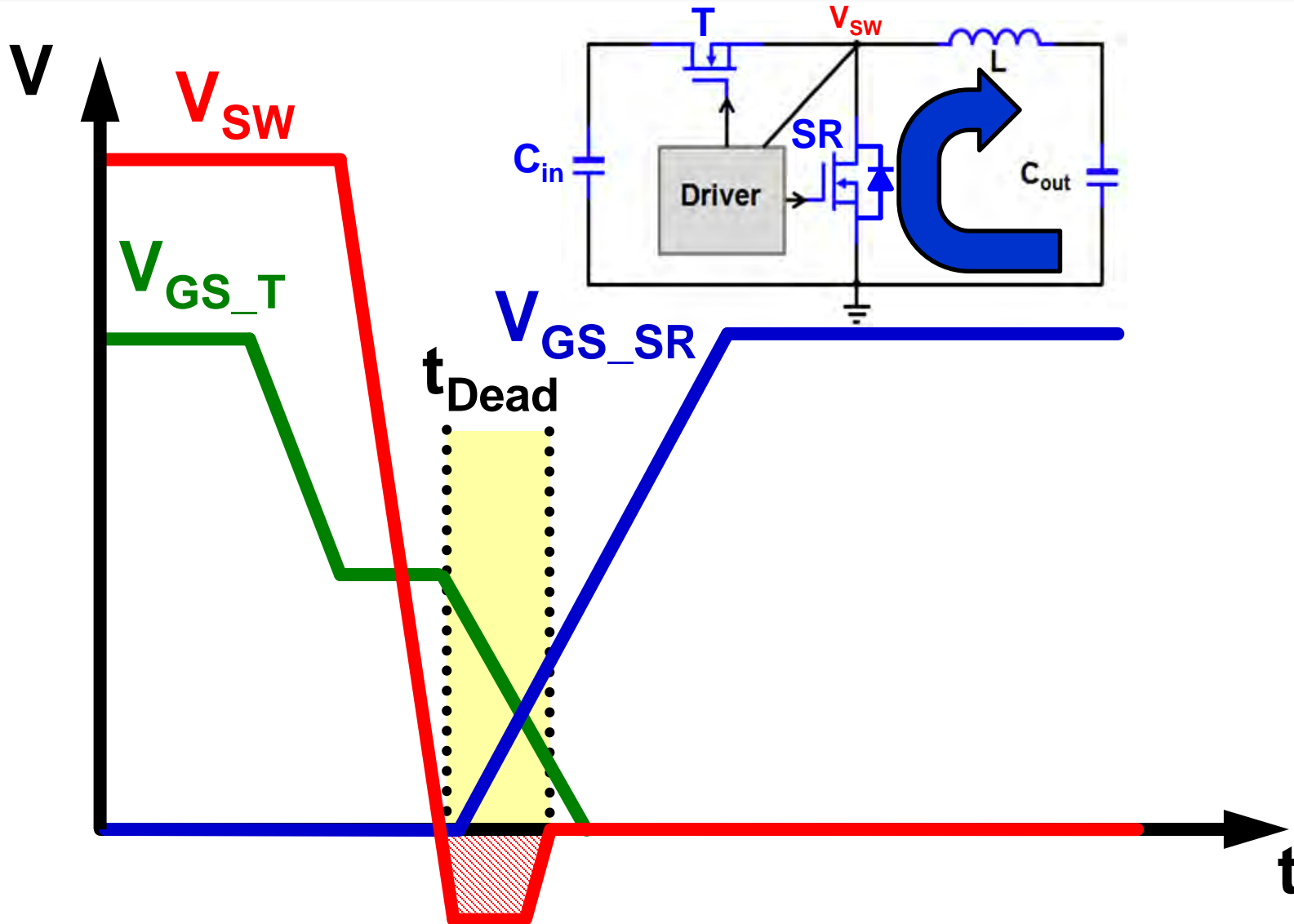
Reference: Texas Instruments, “Gate Drivers for Enhancement Mode GaN Power FETs 100 V Half-Bridge and Low-Side Drivers Enable Greater Efficiency, Power Density, and Simplicity,” SNVB001

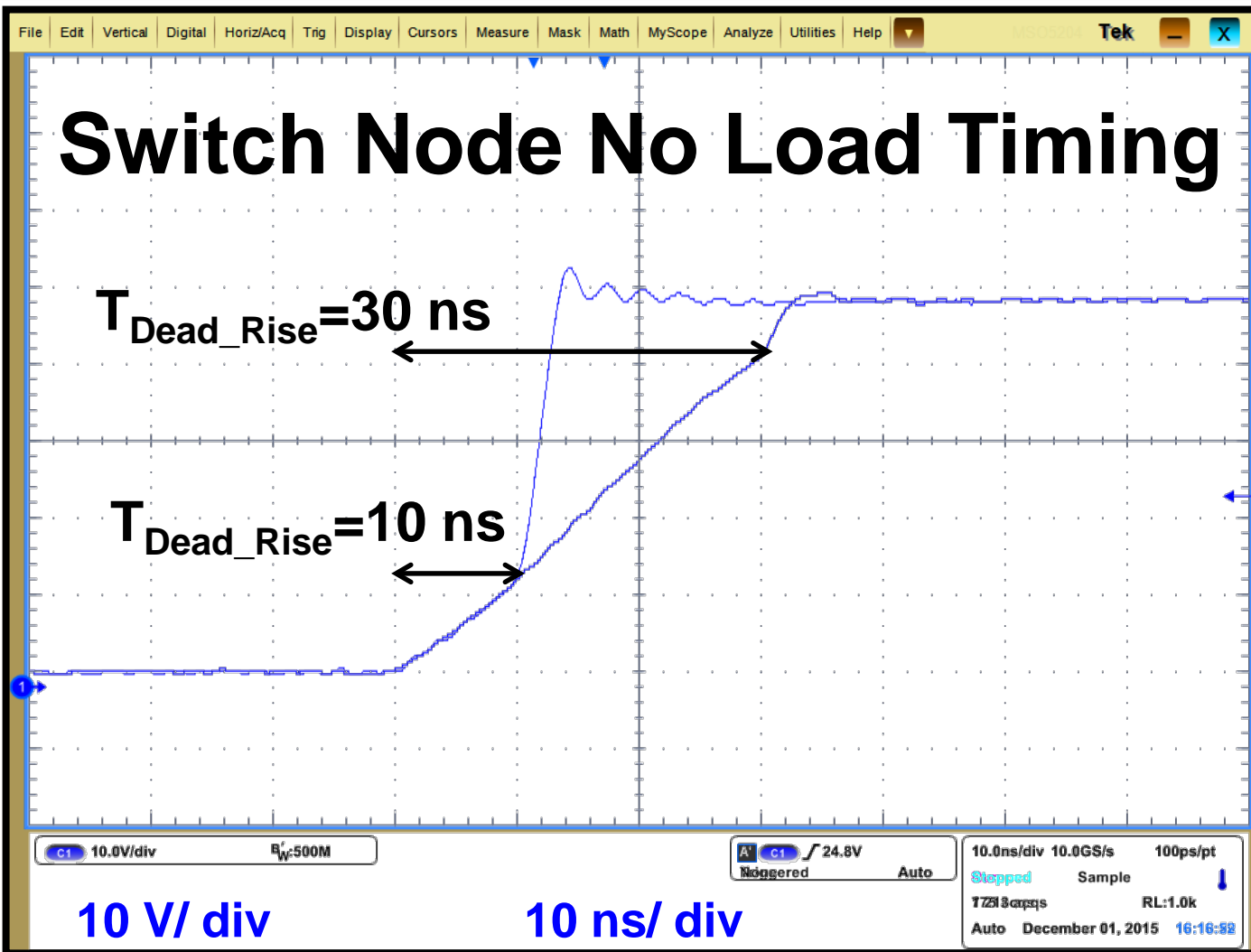


Dead-time

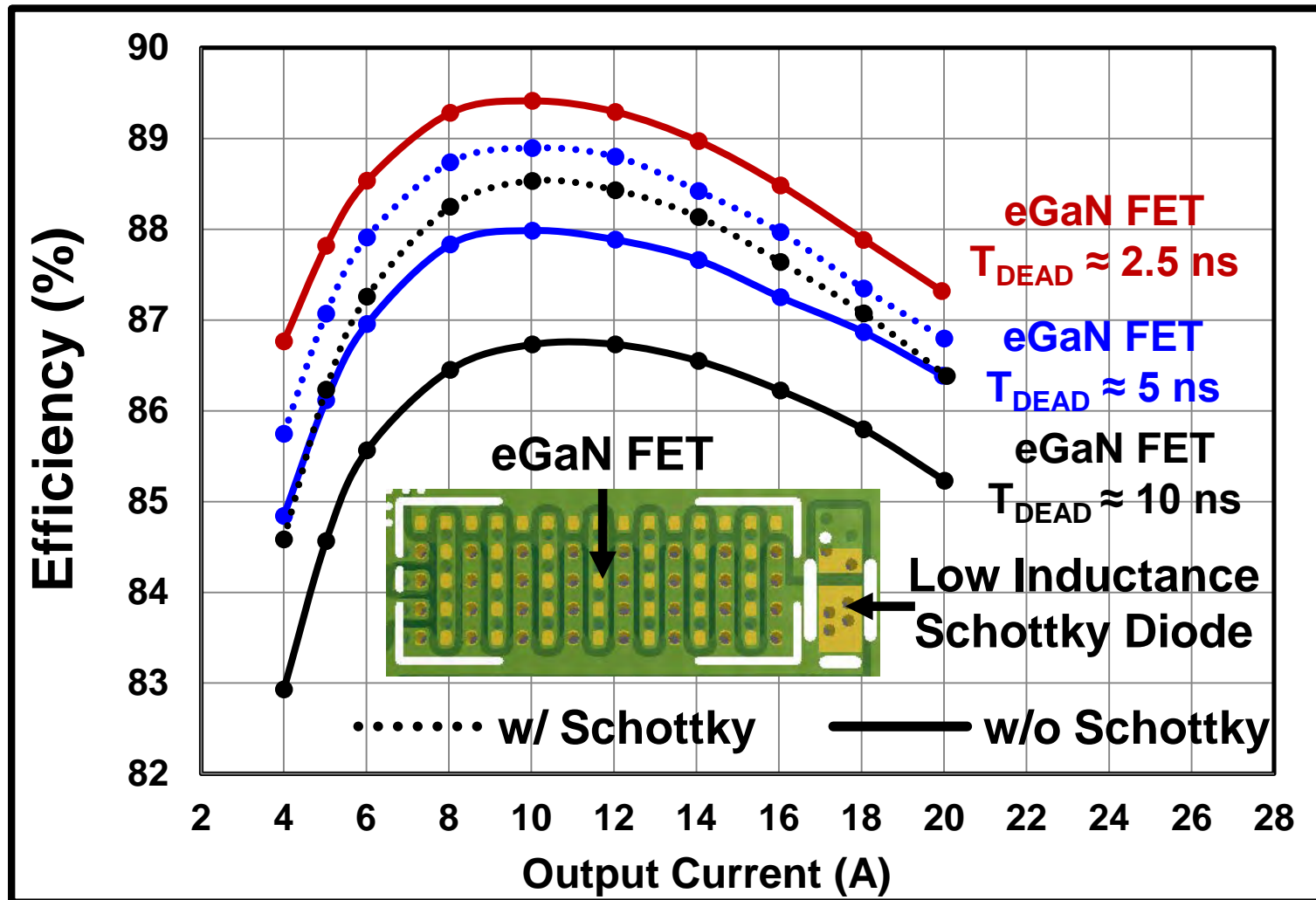




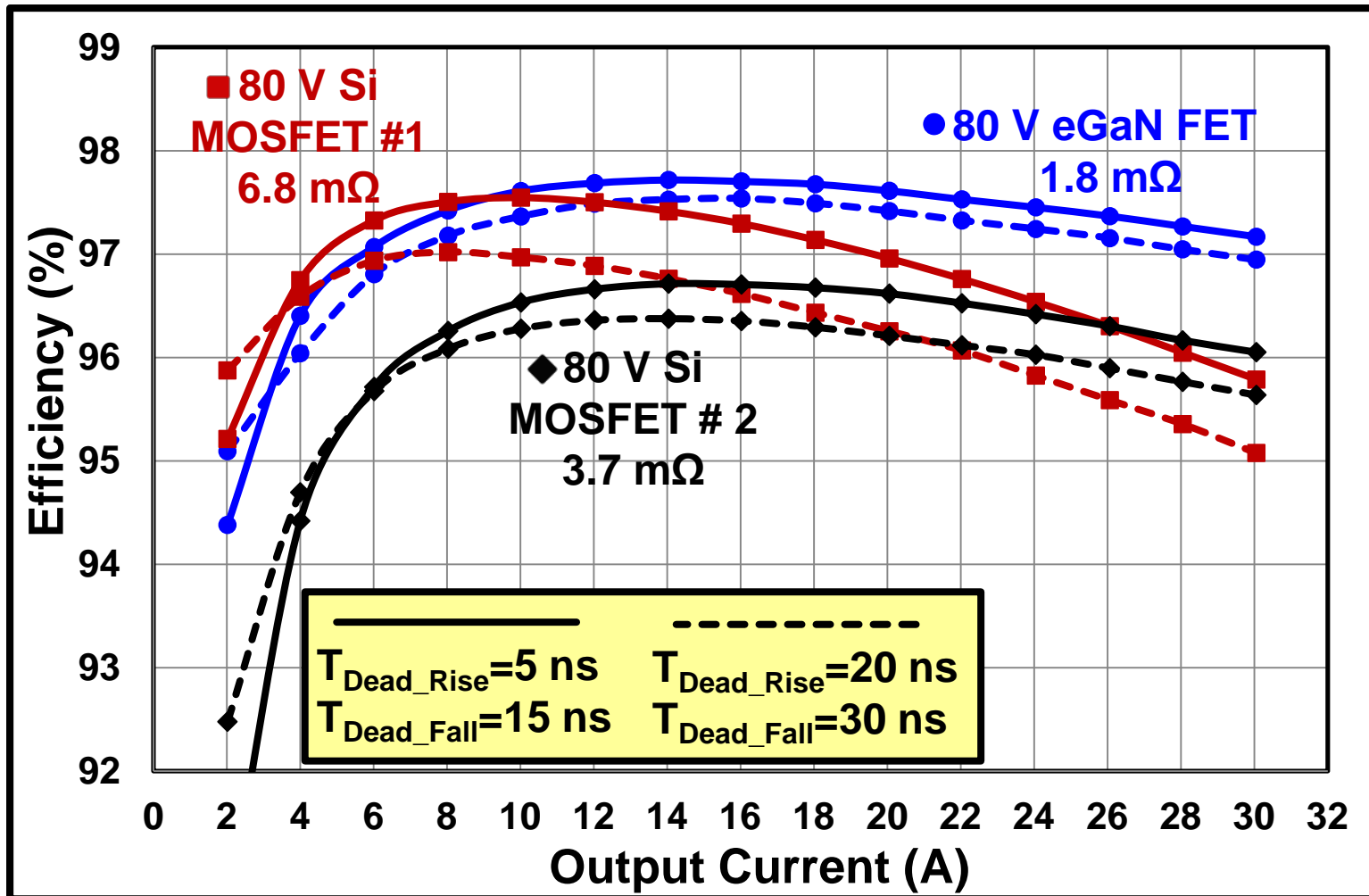




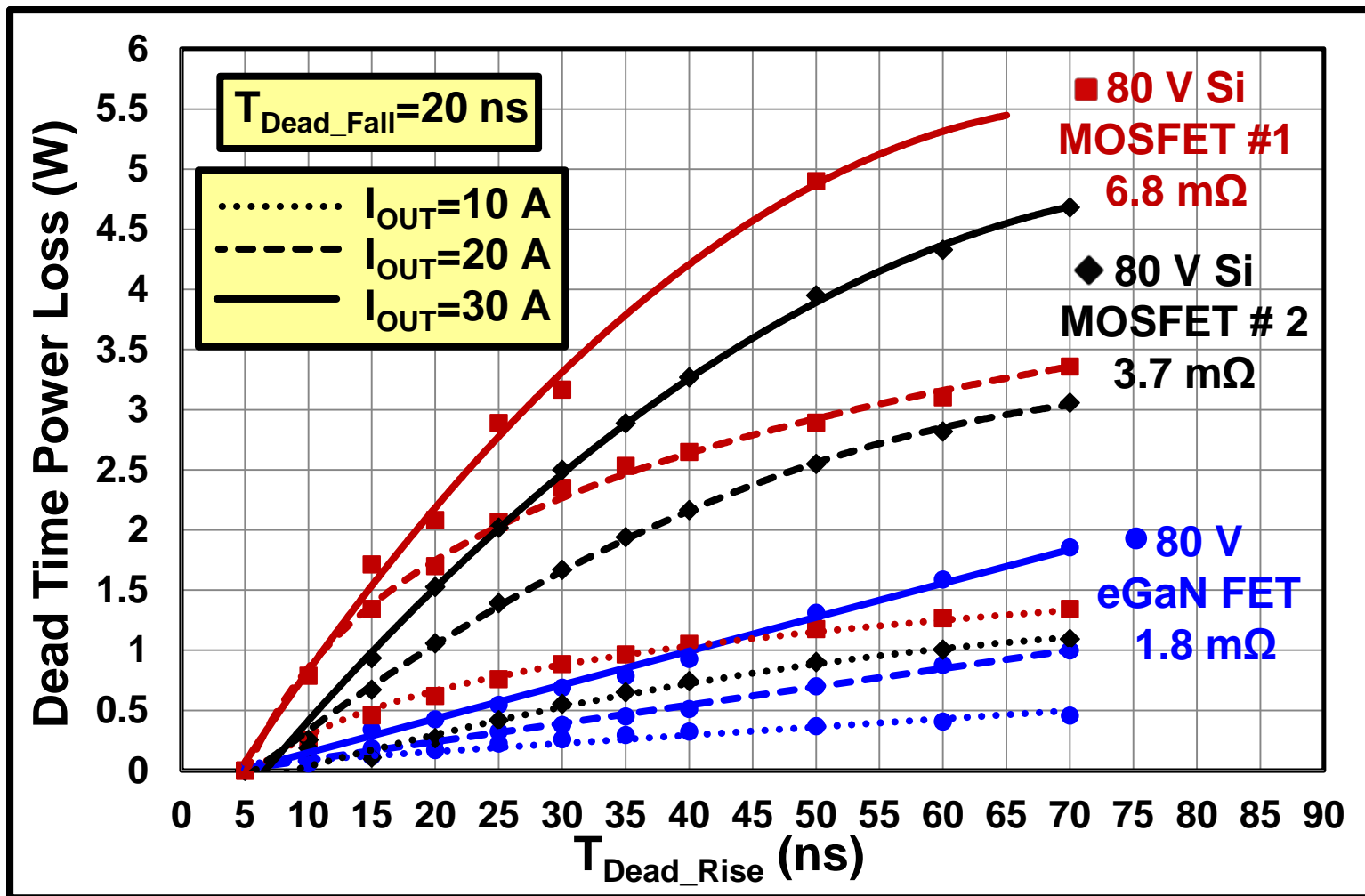
$V_{\text{IN}} = 48 \text{ V}$ $V_{\text{OUT}} \approx 12 \text{ V}$ $I_{\text{OUT}} = 0 \text{ A}$ $f_{\text{sw}} = 300 \text{ kHz}$ $L = 4.7 \mu\text{H}$



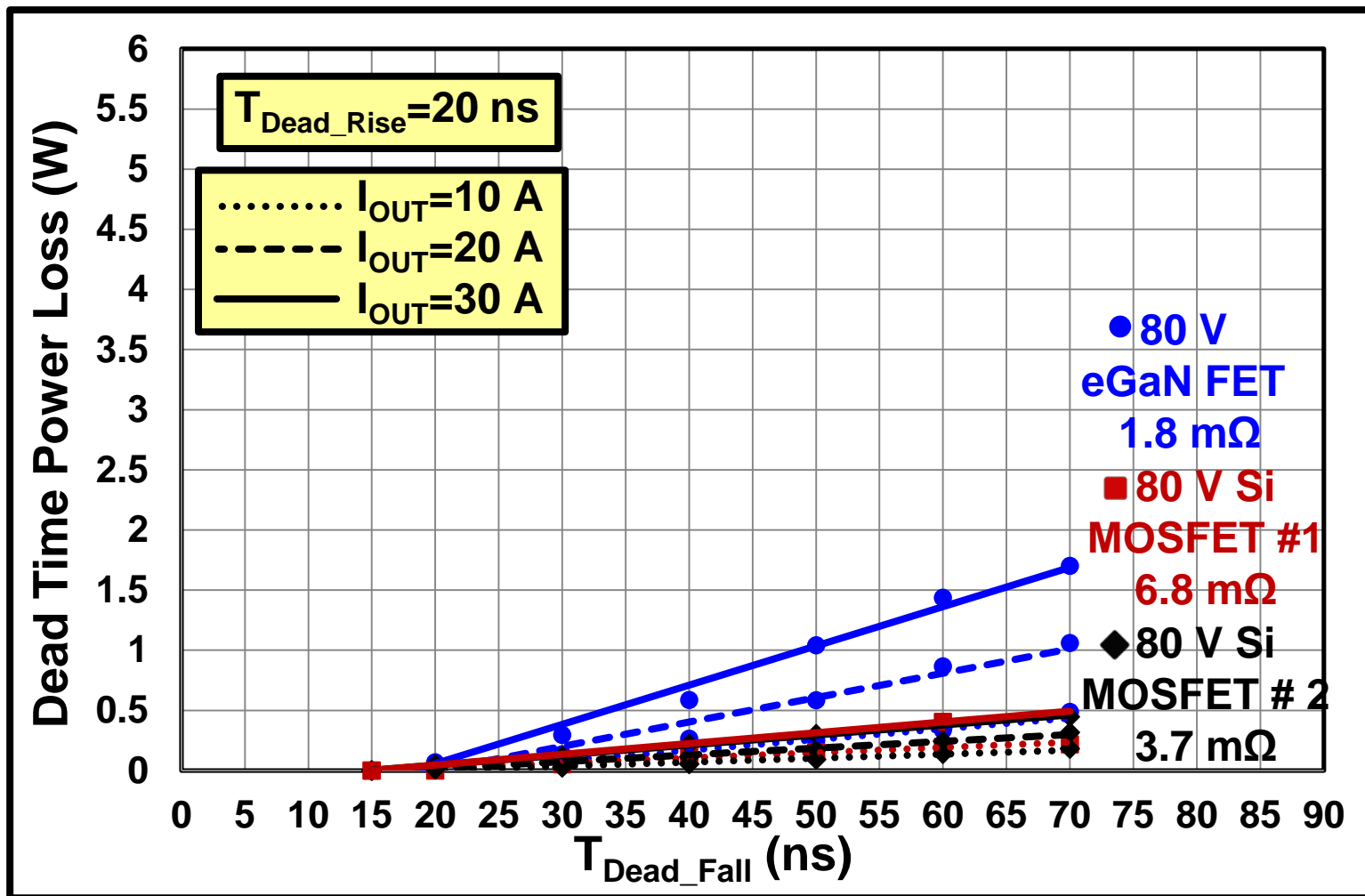
$V_{IN} = 12 \text{ V}$, $V_{OUT} = 1.2 \text{ V}$, and $f_{sw} = 1 \text{ MHz}$



$V_{IN}=48\text{ V}$ $V_{OUT}=12\text{ V}$ $f_{sw}=300\text{ kHz}$ $L=4.7\mu\text{H}$



$V_{IN} = 48$ V $V_{OUT} = 12$ V $f_{sw} = 300$ kHz $L = 4.7$ μ H



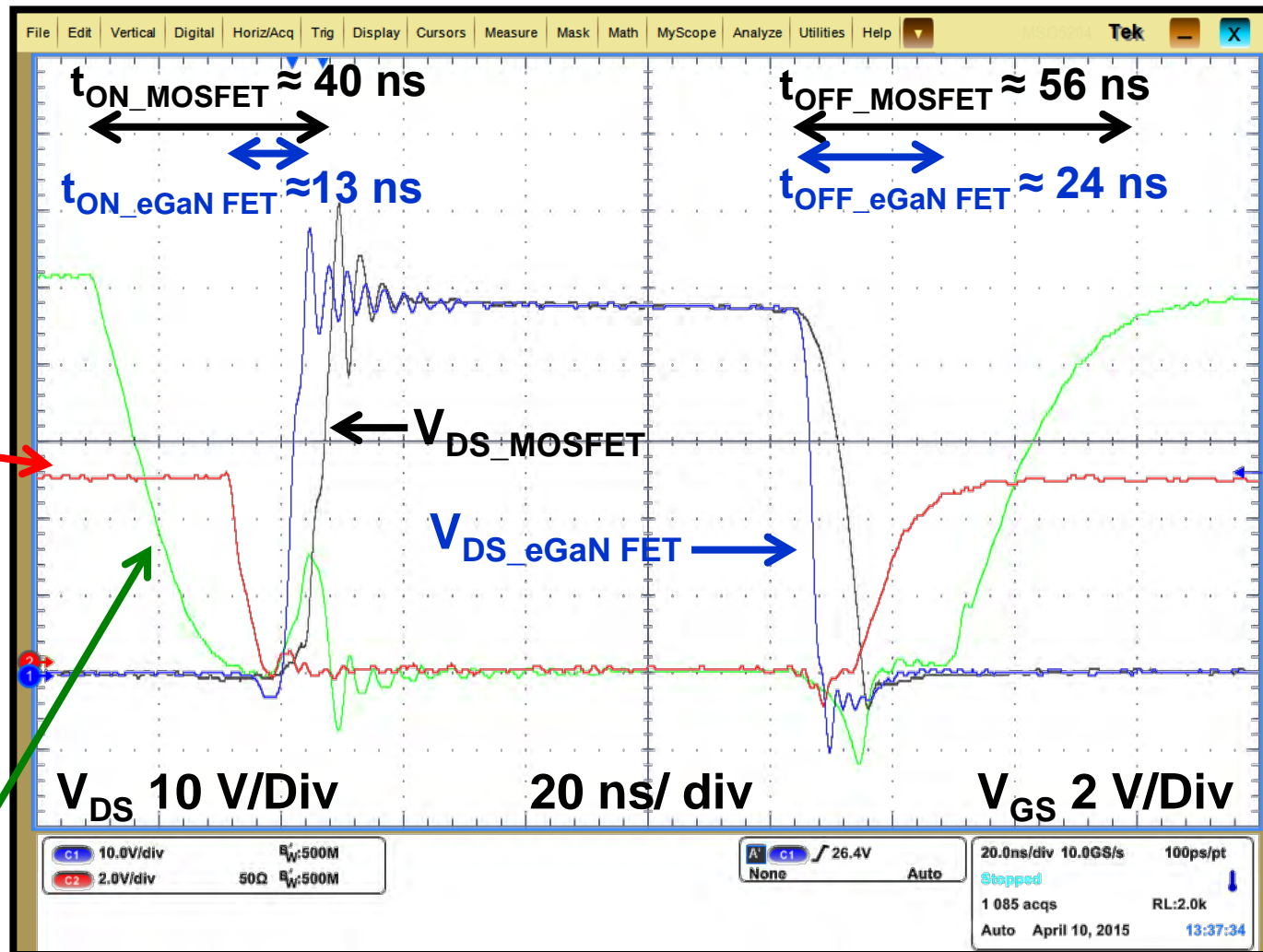
$V_{IN} = 48\text{ V}$ $V_{OUT} = 12\text{ V}$ $f_{sw} = 300\text{ kHz}$ $L = 4.7\text{ uH}$

80 V eGaN FET
1.8 mΩ
13.9 mm²

$V_{DS_eGaN\ FET}$
 $V_{GS_eGaN\ FET}$

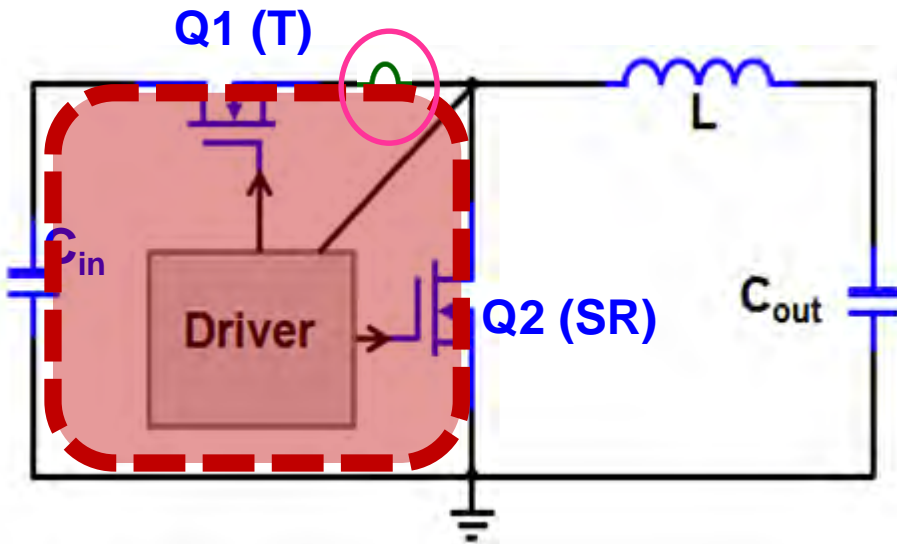
80 V Si MOSFET
3.7 mΩ
31 mm²

V_{GS_MOSFET}
 V_{DS_MOSFET}



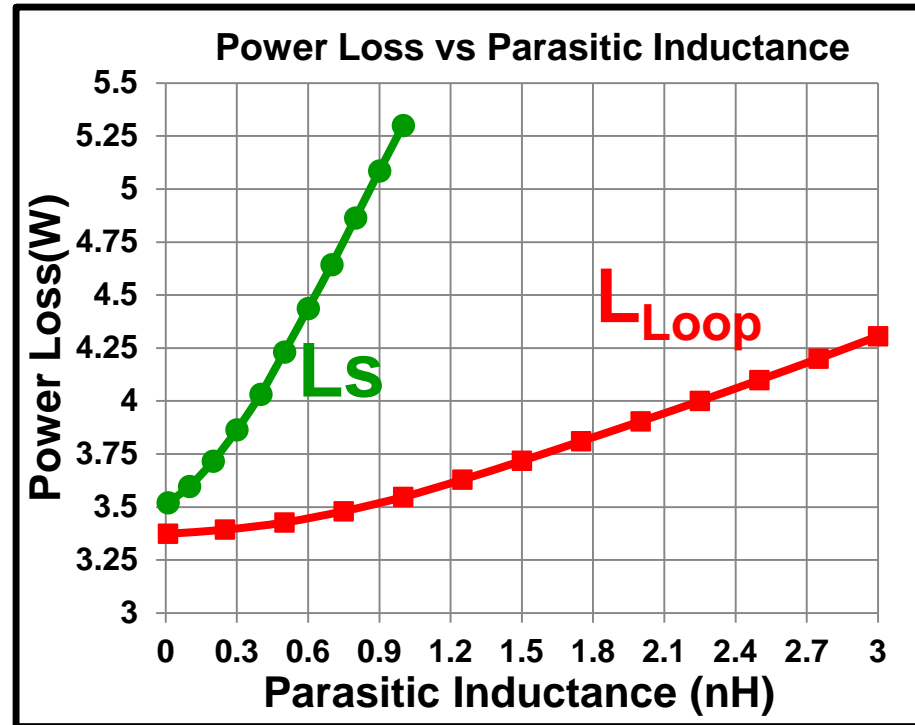
$V_{IN}=48\text{ V } V_{OUT}=1\text{ V } I_{OUT}=30\text{ A}$

Layout

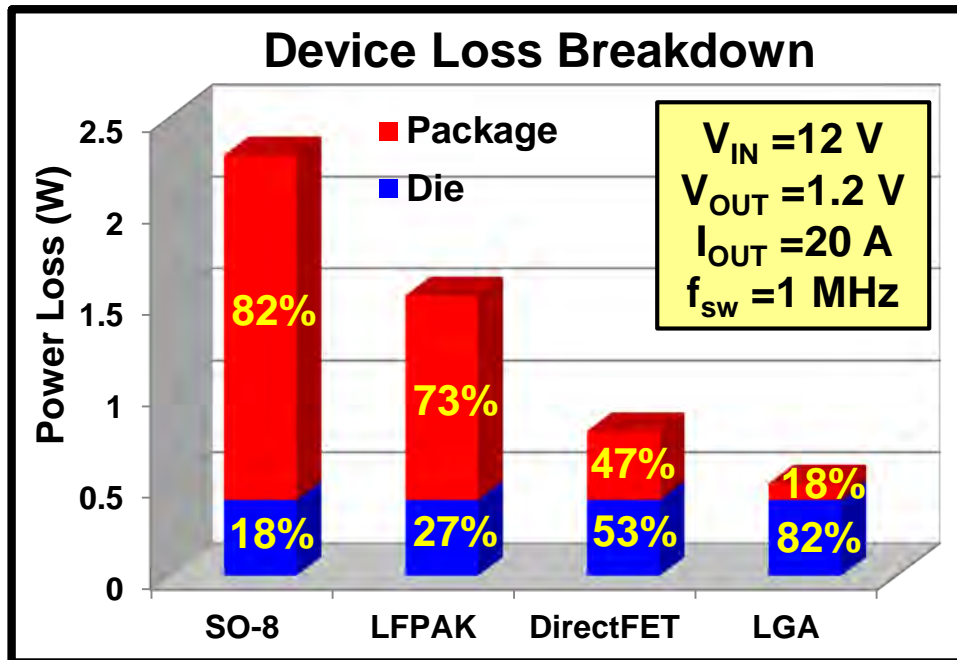
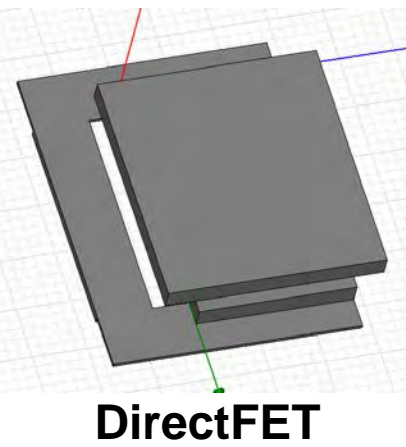
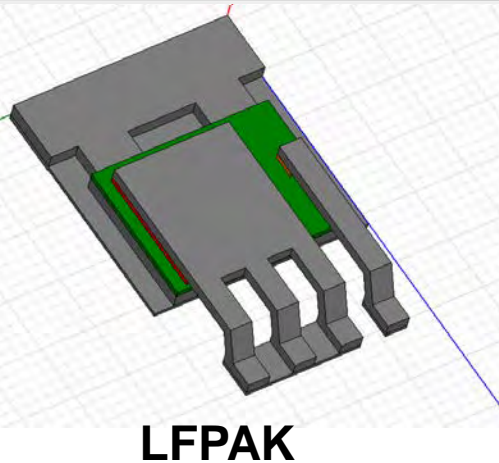
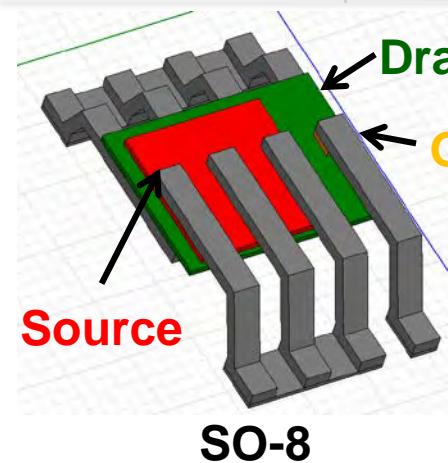


L_S : Common Source Inductance

L_{Loop} : High Frequency Power Loop Inductance

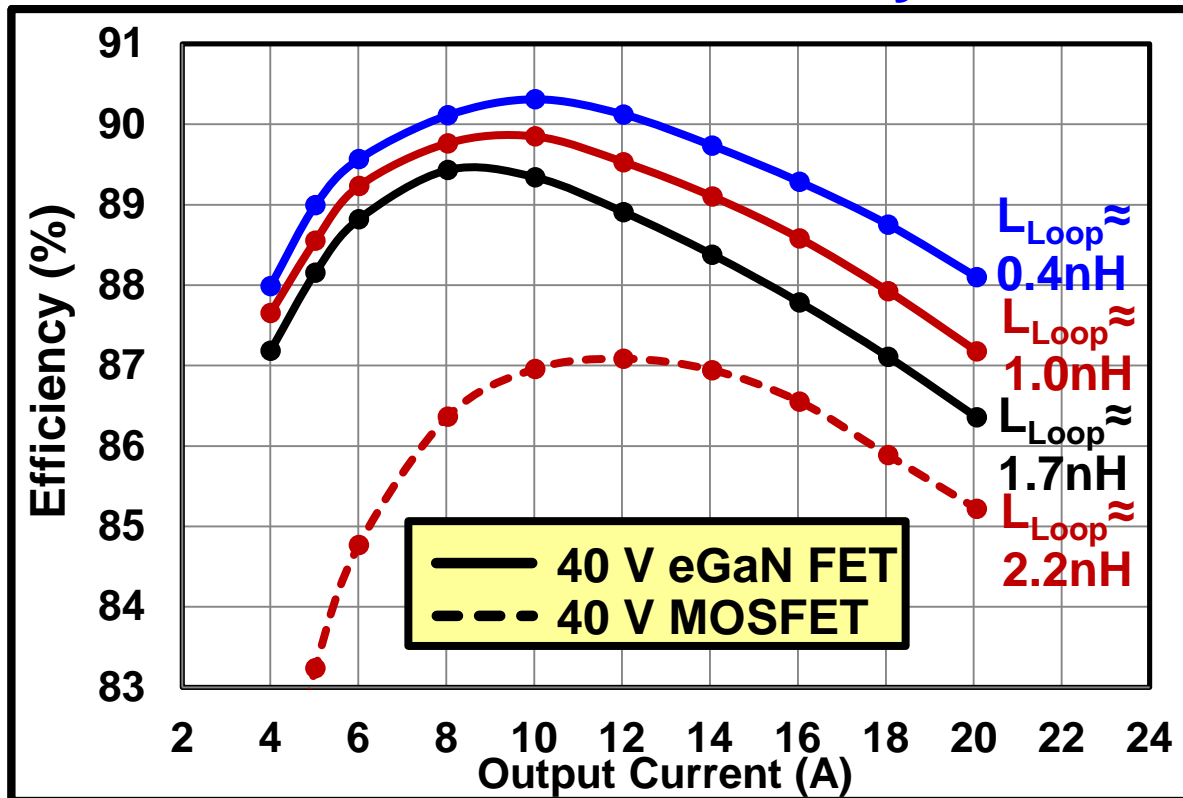


$V_{IN}=12\text{ V}$, $V_{OUT}=1.2\text{ V}$,
 $f_{sw}=1\text{ MHz}$, $I_{OUT}=20\text{ A}$



Reference: D. Reusch, D. Gilham, Y. Su, and F.C. Lee, C, "Gallium Nitride Based 3D Integrated Non-Isolated Point of Load Module," APEC 2012

Measured Efficiency



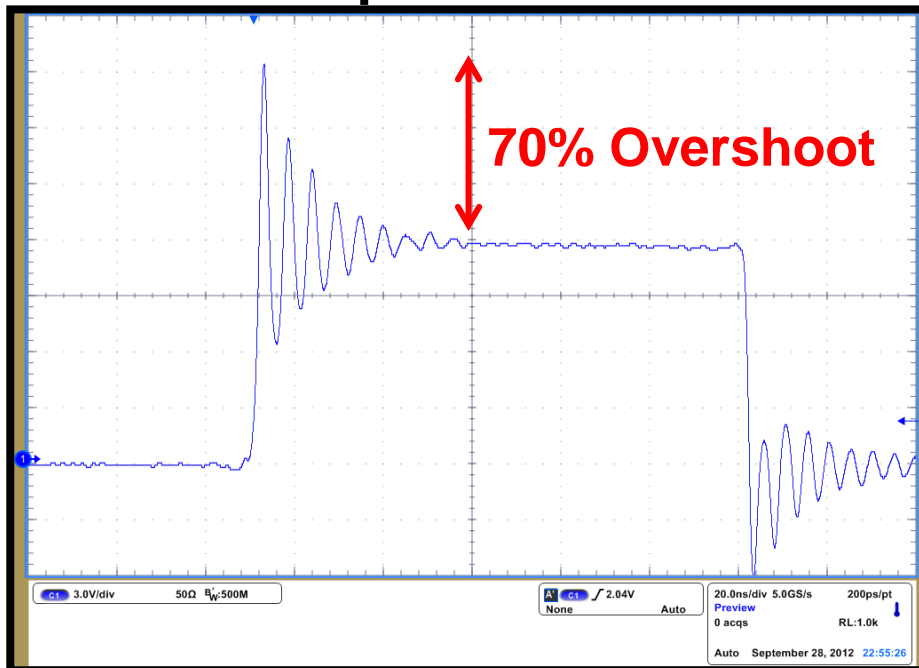
$V_{IN}=12\text{ V}, V_{OUT}=1.2\text{ V}, f_{sw}=1\text{ MHz}, L=300\text{ nH}$

EPC Optimal Layout

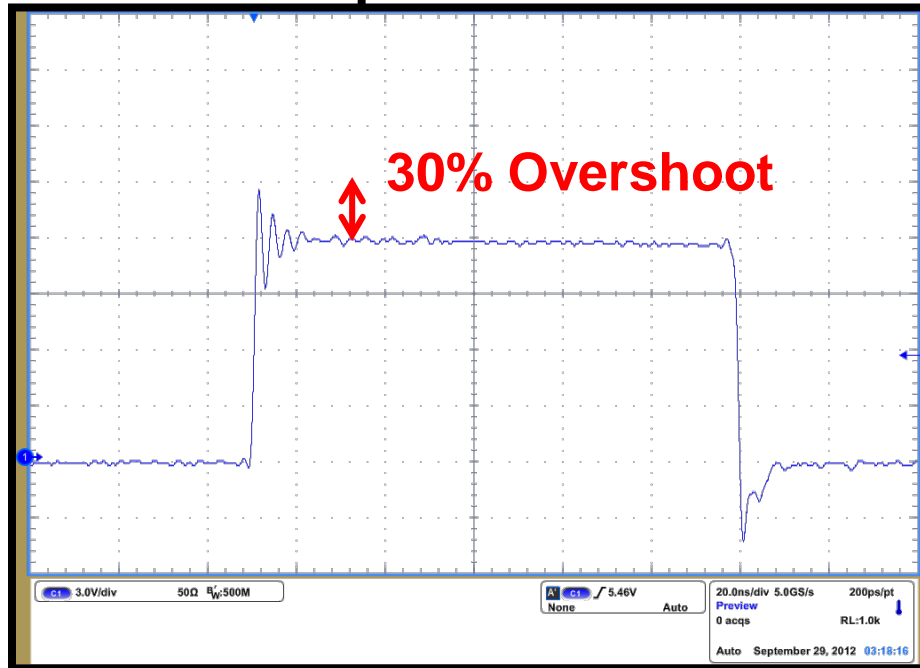


Ref: D. Reusch, J. Strydom,
 "Understanding the Effect of PCB Layout
 on Circuit Performance in a High
 Frequency Gallium Nitride Based Point of
 Load Converter,"
 APEC 2013, IEEE Transactions on Power
 Electronics 2014

$L_{Loop} \approx 1.0 \text{ nH}$



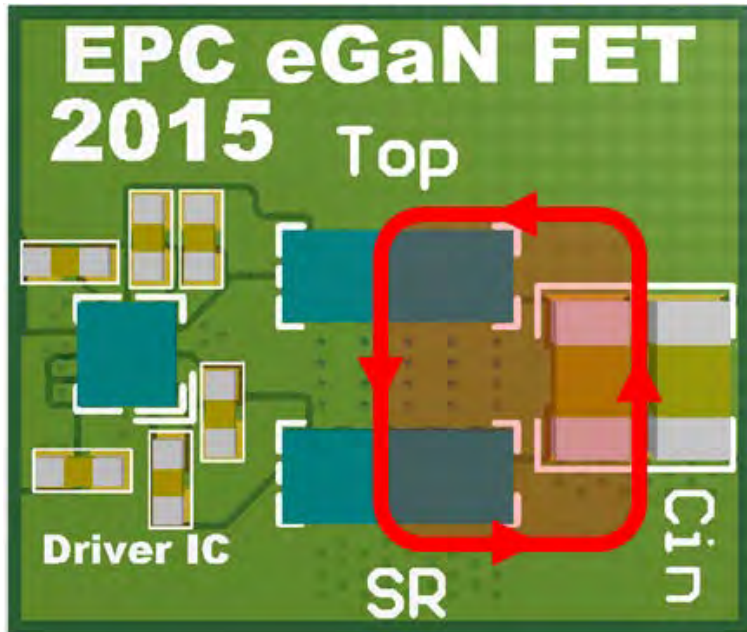
$L_{Loop} \approx 0.4 \text{ nH}$



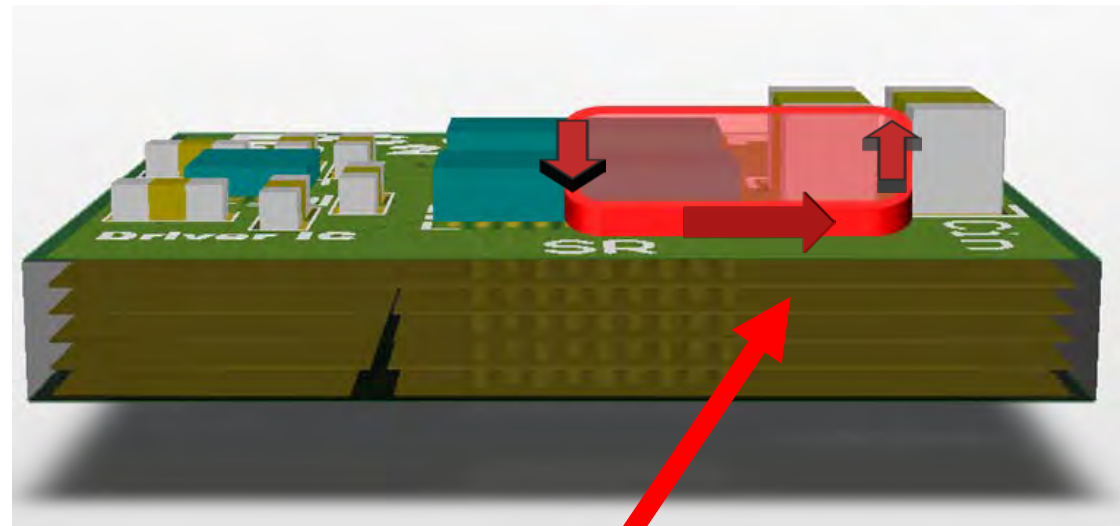
Switching Node Voltage

$V_{IN}=12 \text{ V}$ $V_{OUT}=1.2 \text{ V}$ $I_{OUT}=20 \text{ A}$
 $f_{sw}=1 \text{ MHz}$ $L=150 \text{ nH}$

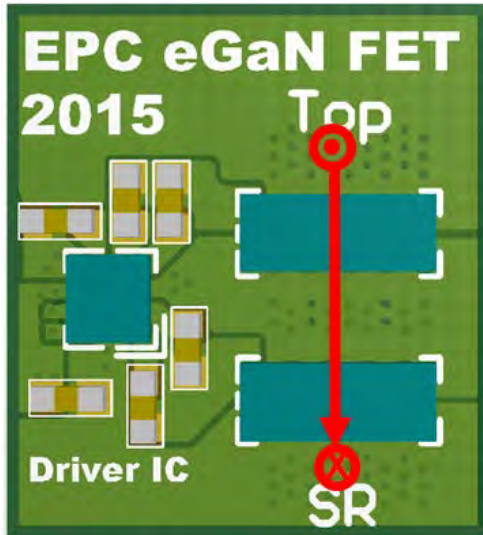
Top View



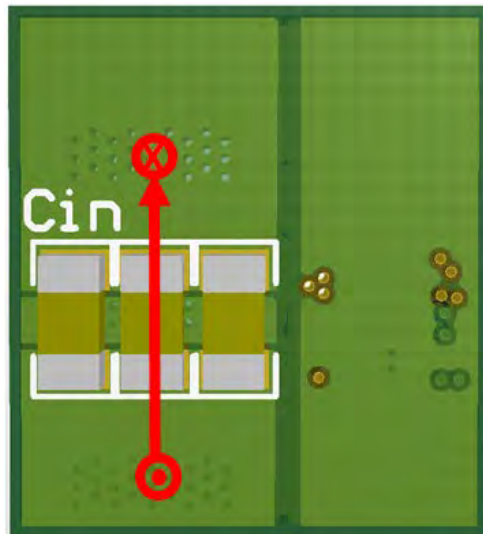
Side View



Shield Layer

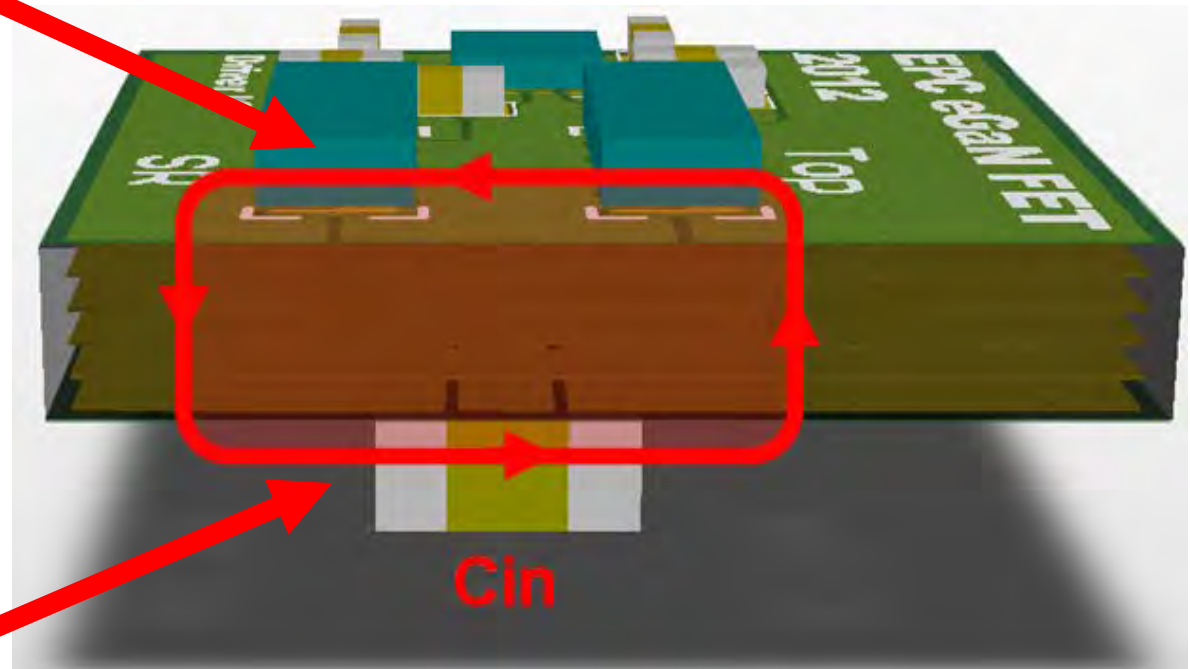


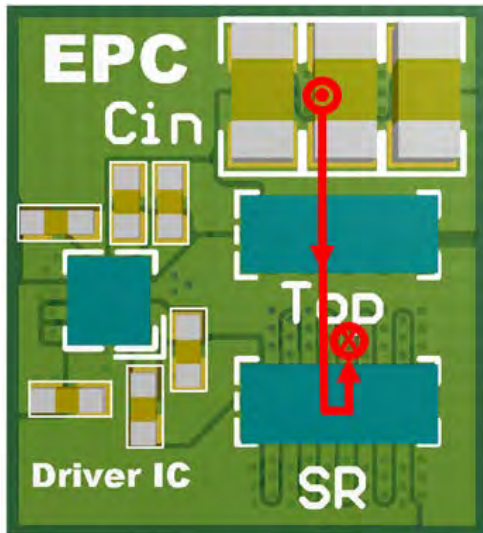
Top View



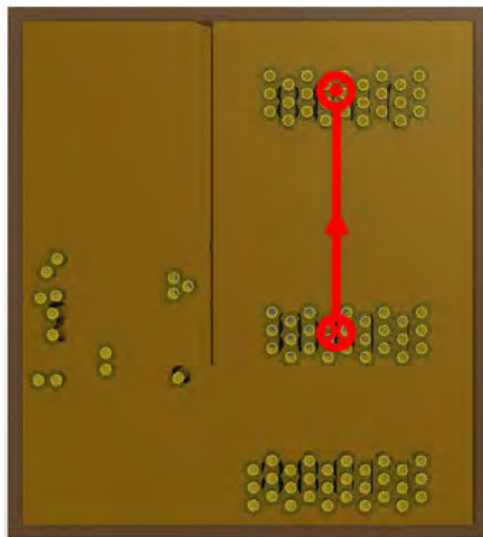
Bottom View

Side View



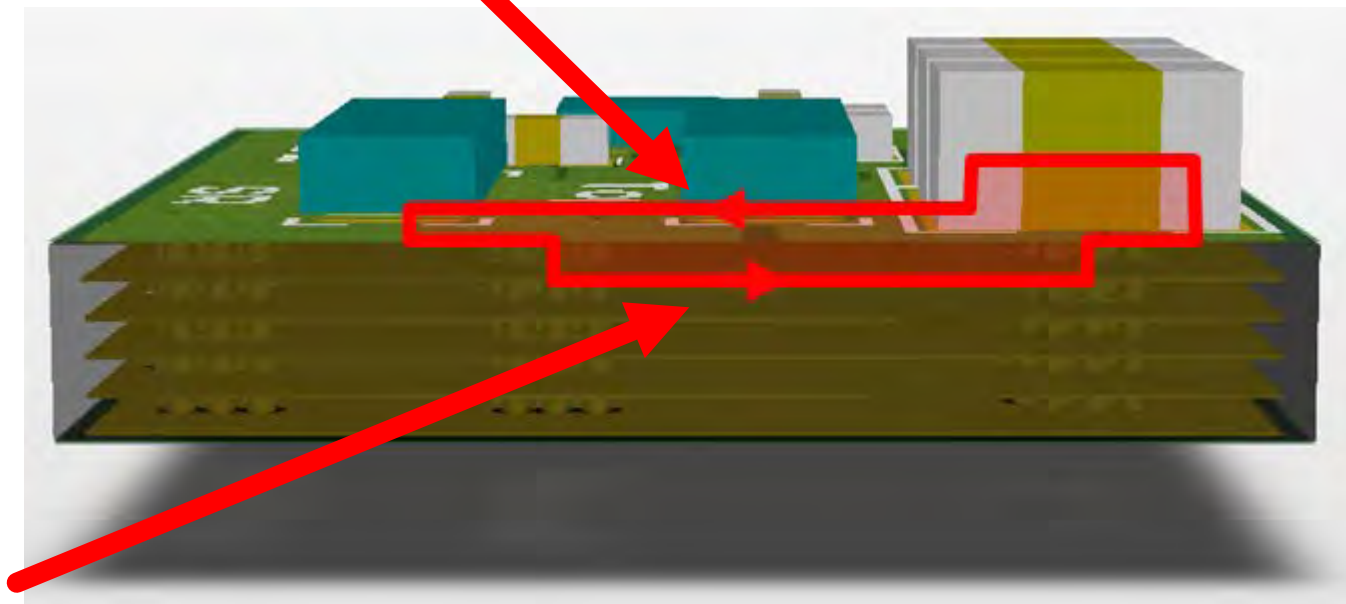


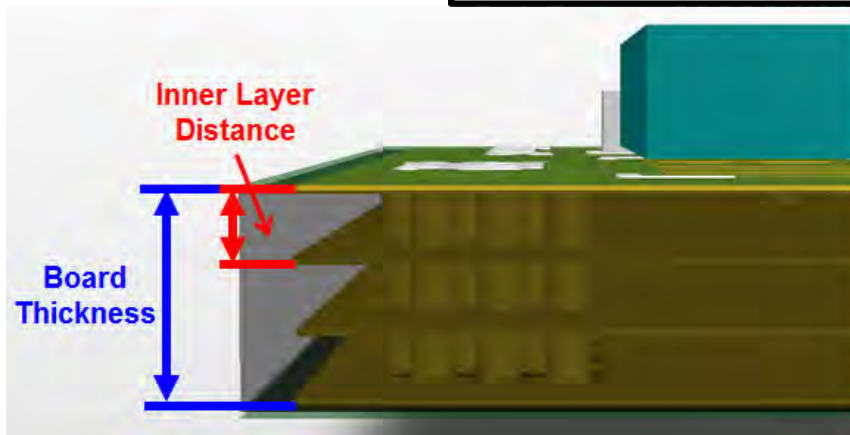
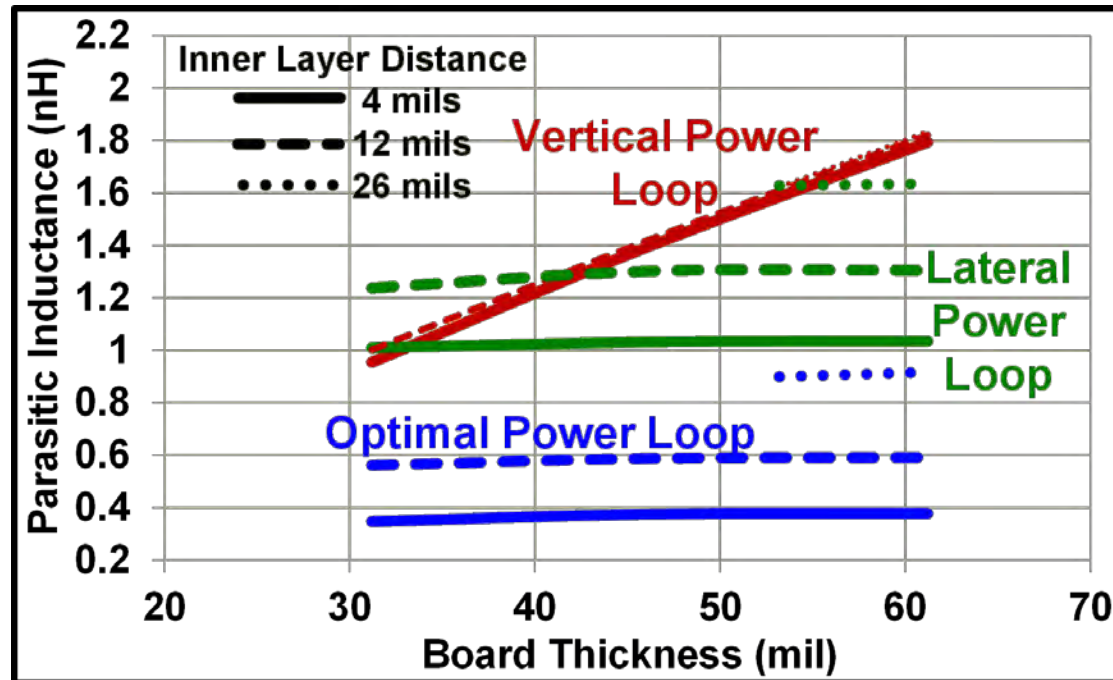
Top View



Top View Inner Layer 1

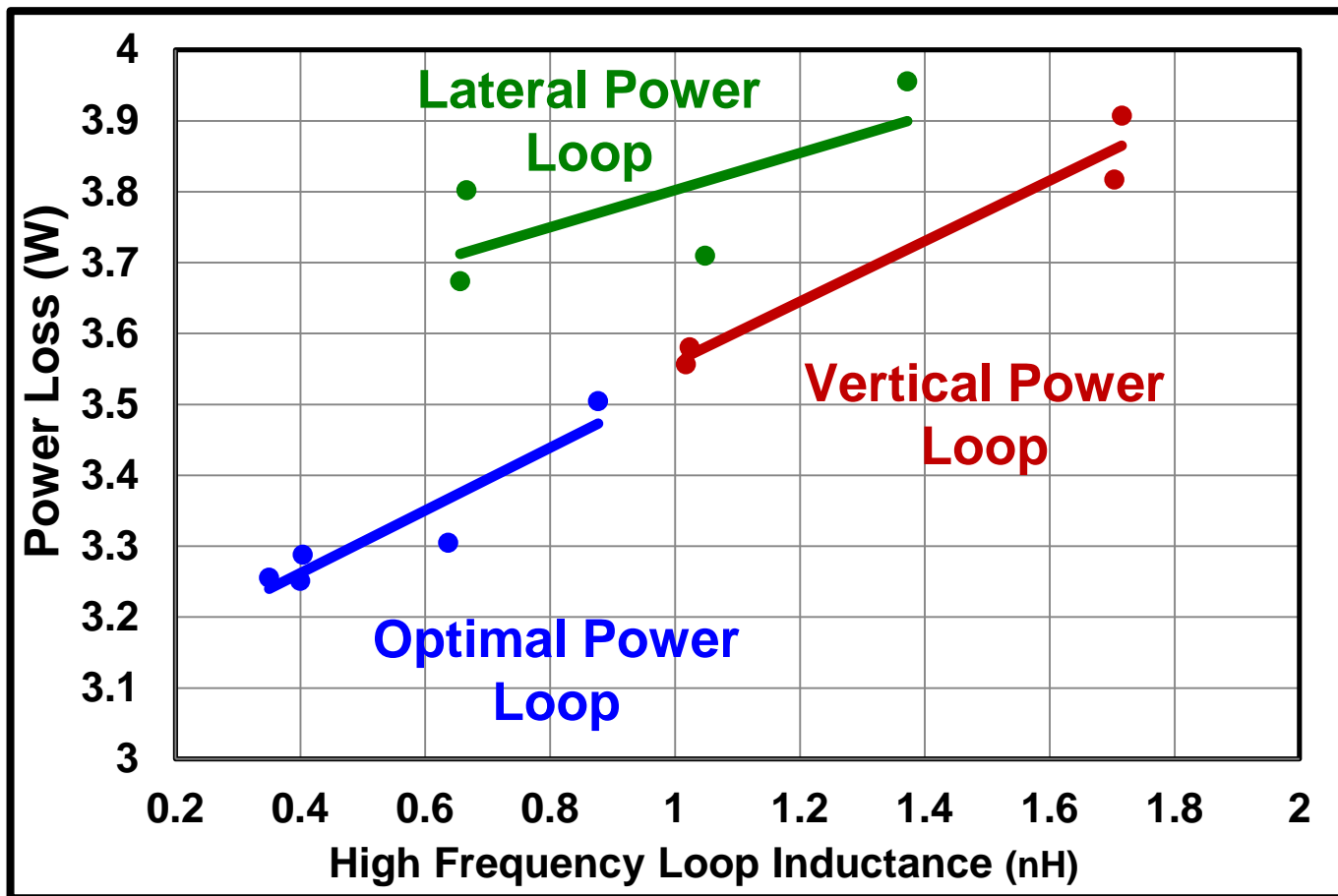
Side View



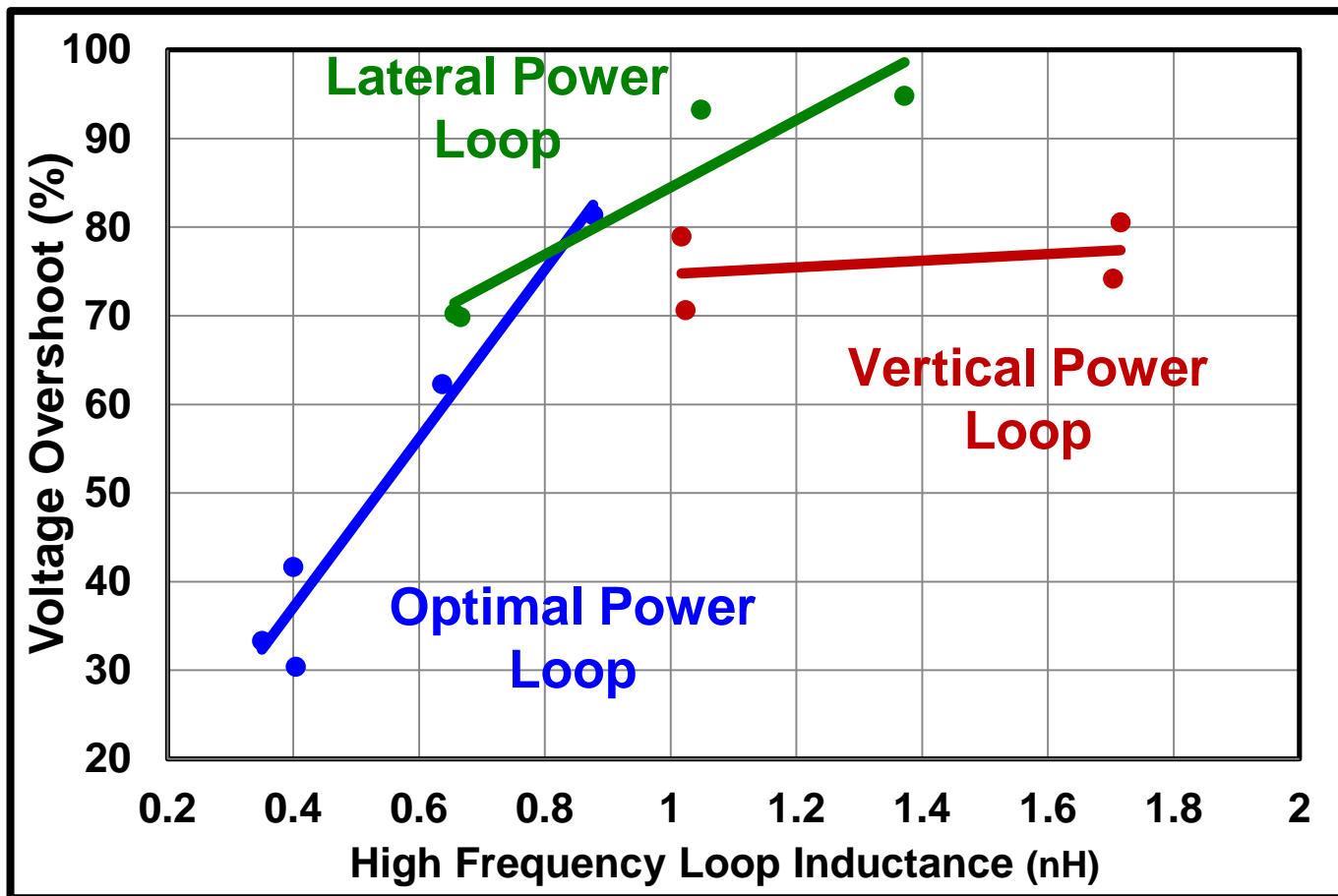


Test Cases

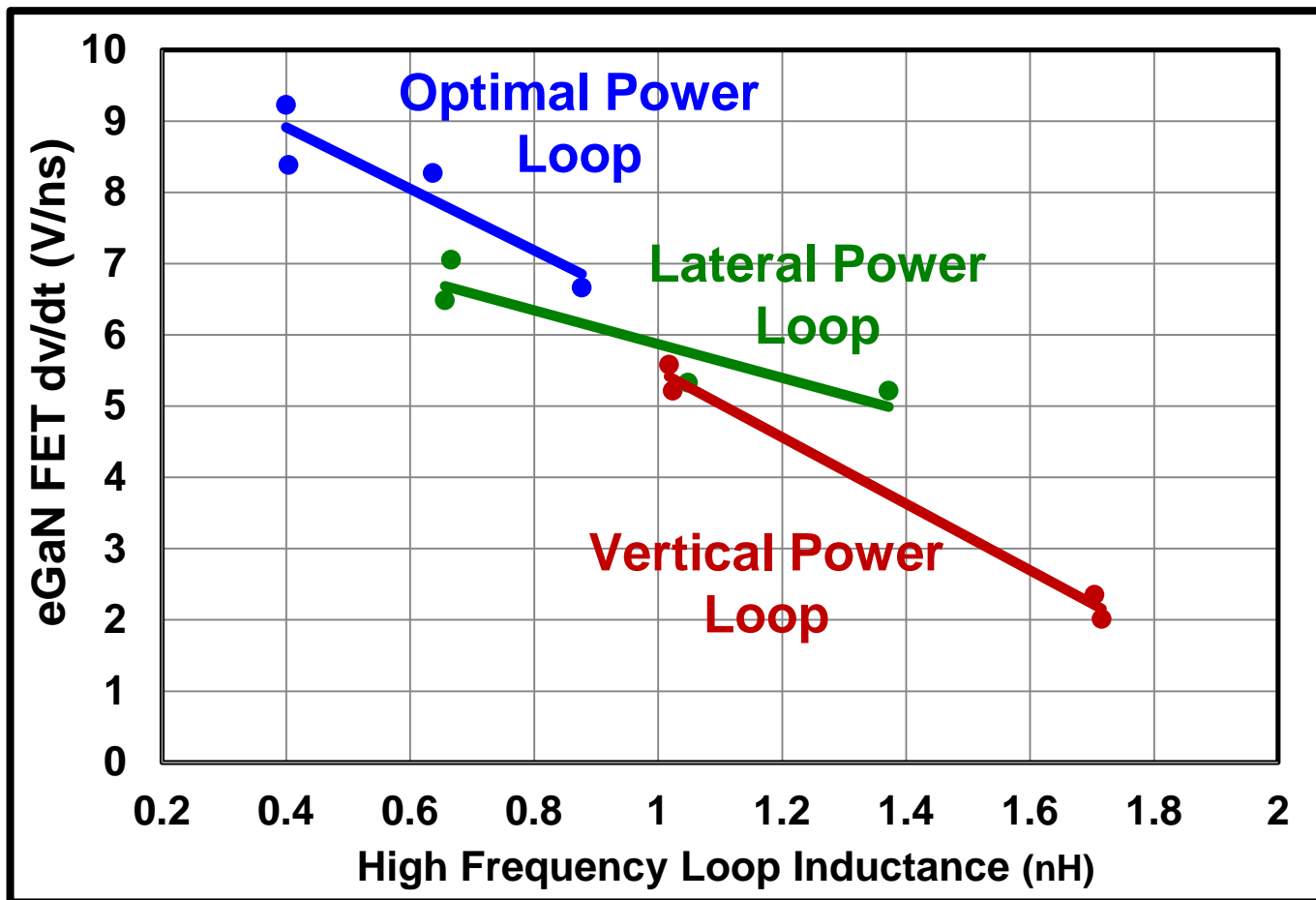
	Board Thickness (mils)	Inner Layer Distance (mils)
Design 1	31	4
Design 2	31	12
Design 3	62	4
Design 4	62	26



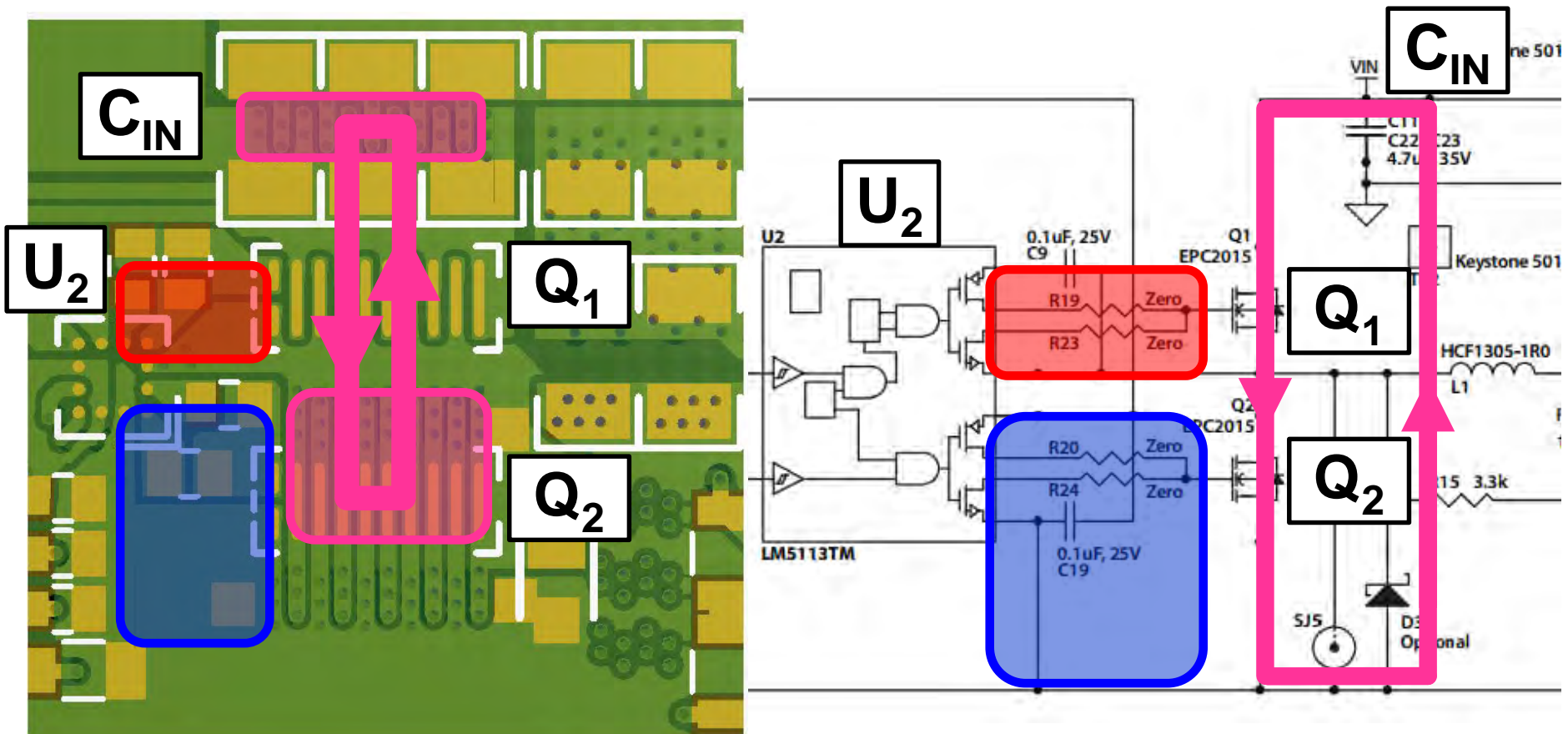
$V_{IN}=12\text{ V}$ $V_{OUT}=1.2\text{ V}$ $I_{OUT}=20\text{ A}$ $f_{sw}=1\text{ MHz}$ $L=300\text{ nH}$
T/SR: EPC2015 Driver LM5113



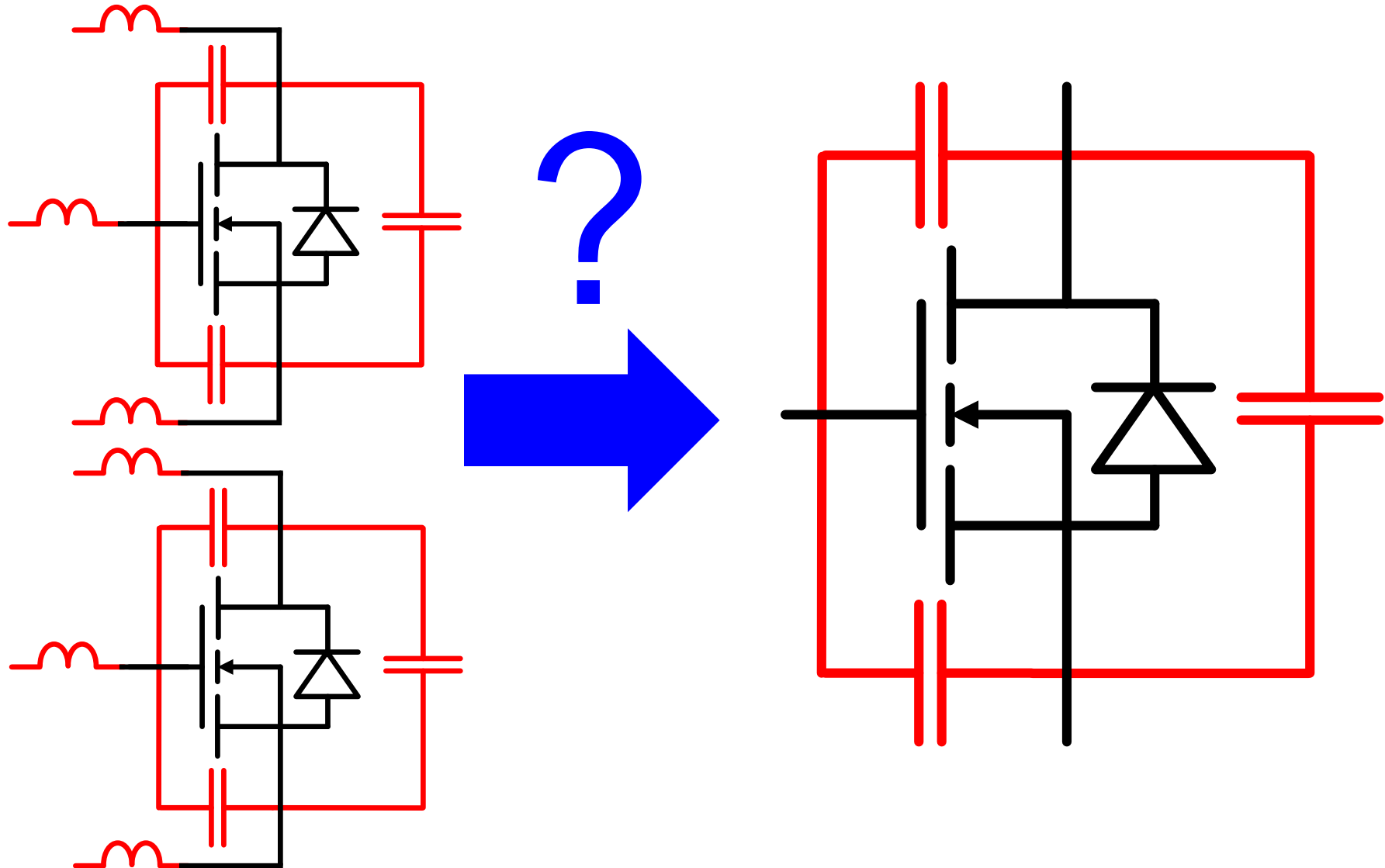
$V_{IN}=12\text{ V}$ $V_{OUT}=1.2\text{ V}$ $I_{OUT}=20\text{ A}$ $f_{sw}=1\text{ MHz}$ $L=300\text{ nH}$
T/SR: EPC2015 Driver LM5113

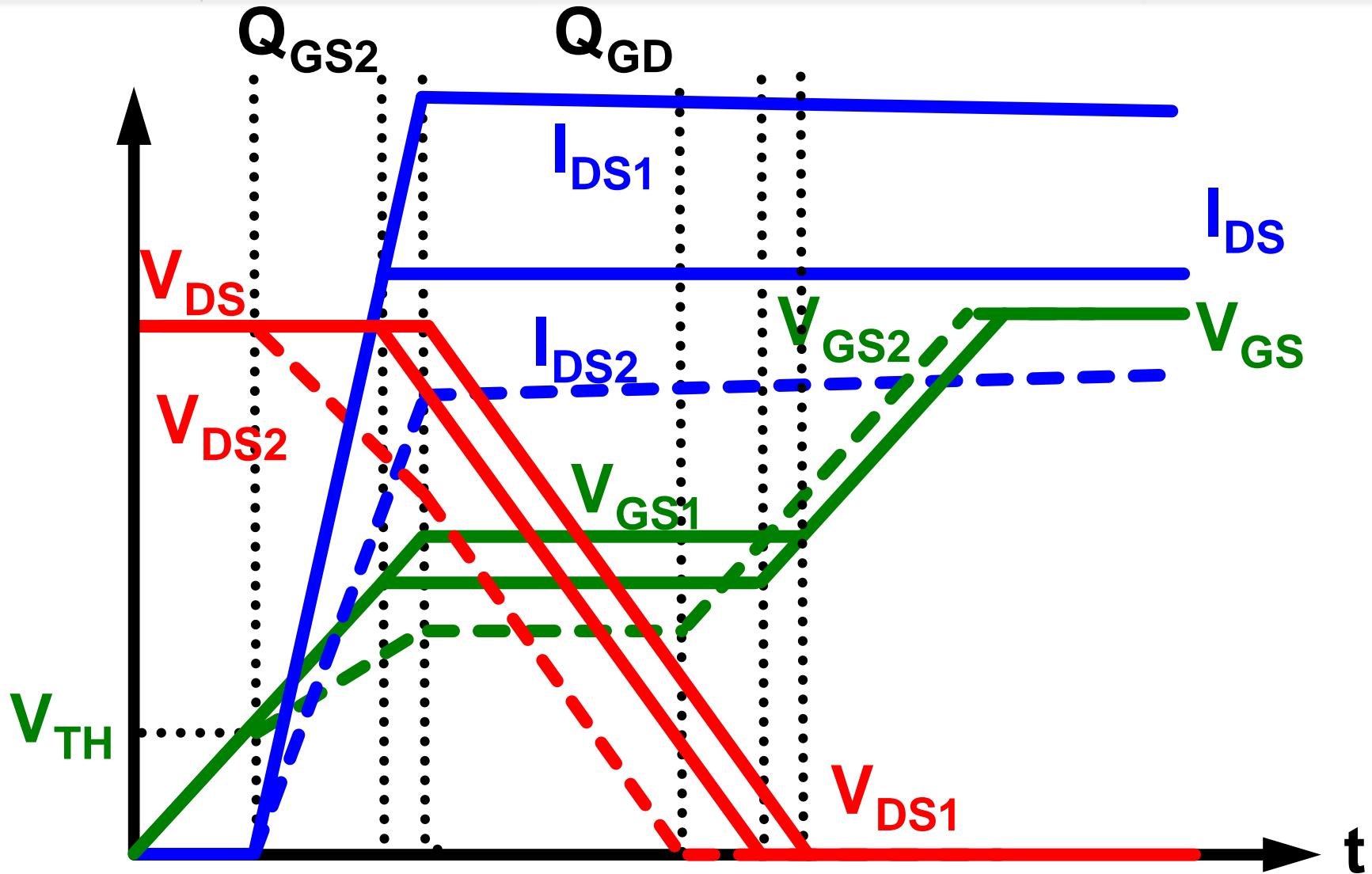


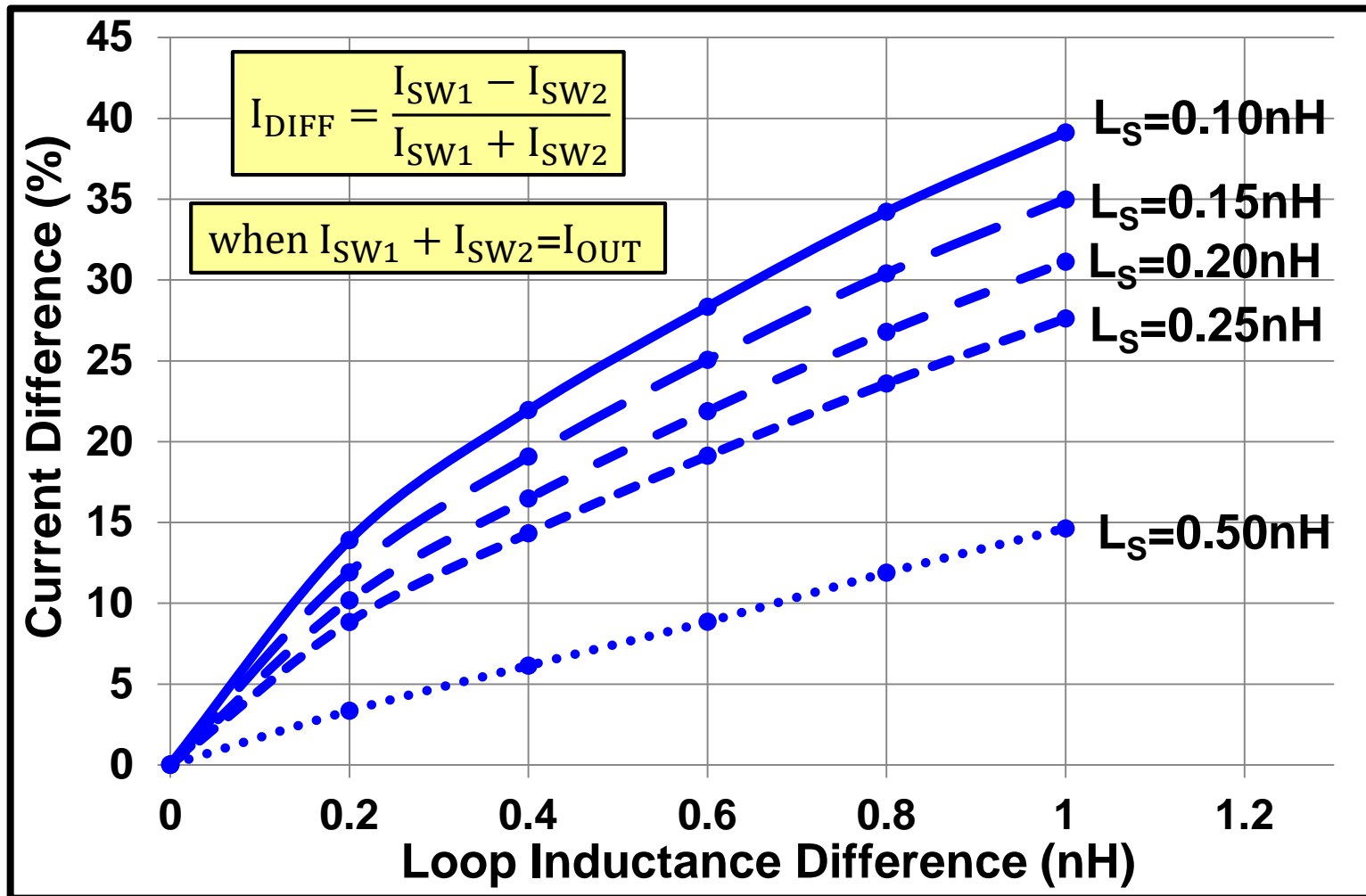
$V_{IN}=12\text{ V}$ $V_{OUT}=1.2\text{ V}$ $I_{OUT}=20\text{ A}$ $f_{sw}=1\text{ MHz}$ $L=300\text{ nH}$
T/SR: EPC2015 Driver LM5113



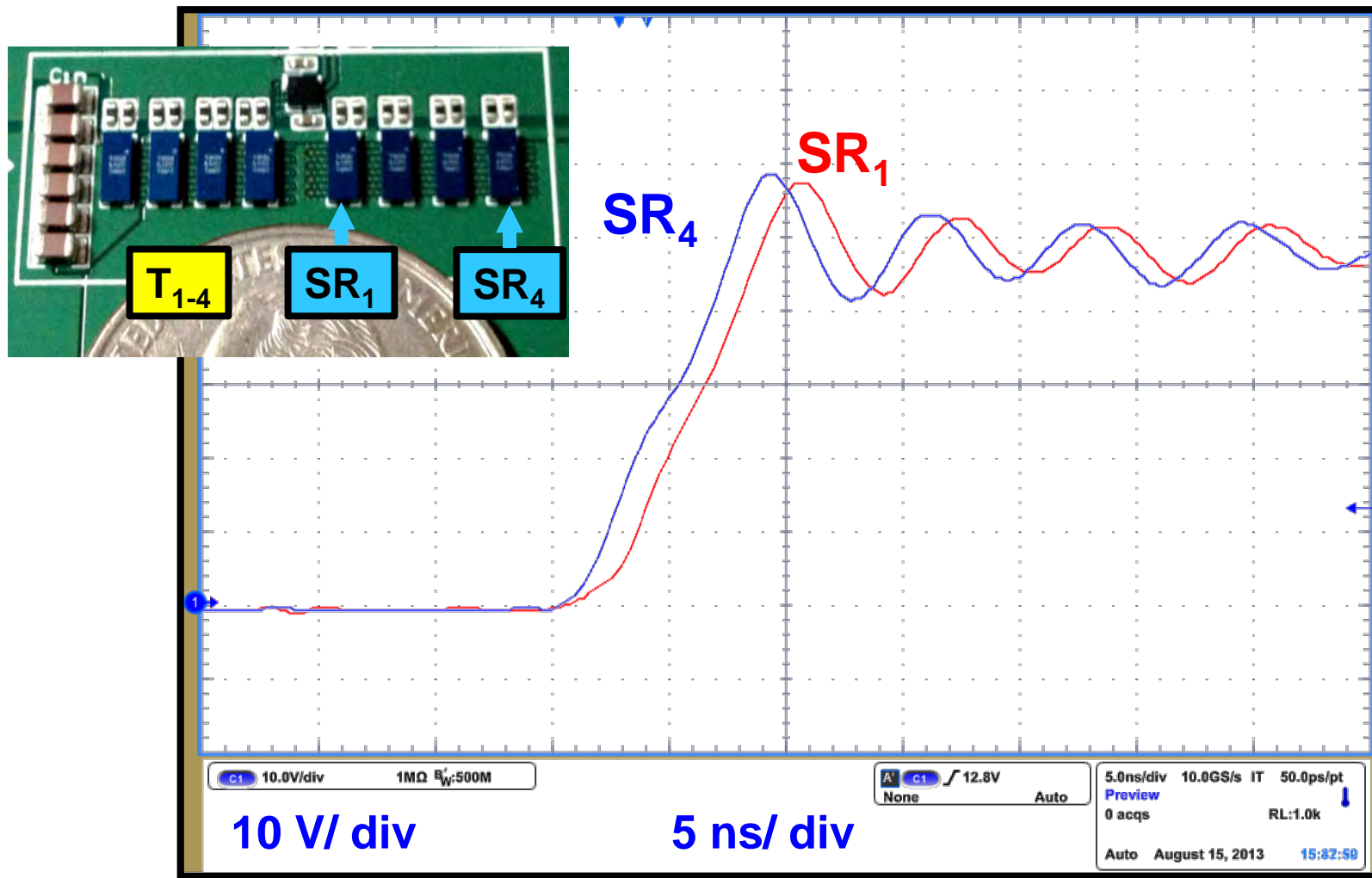
Paralleling



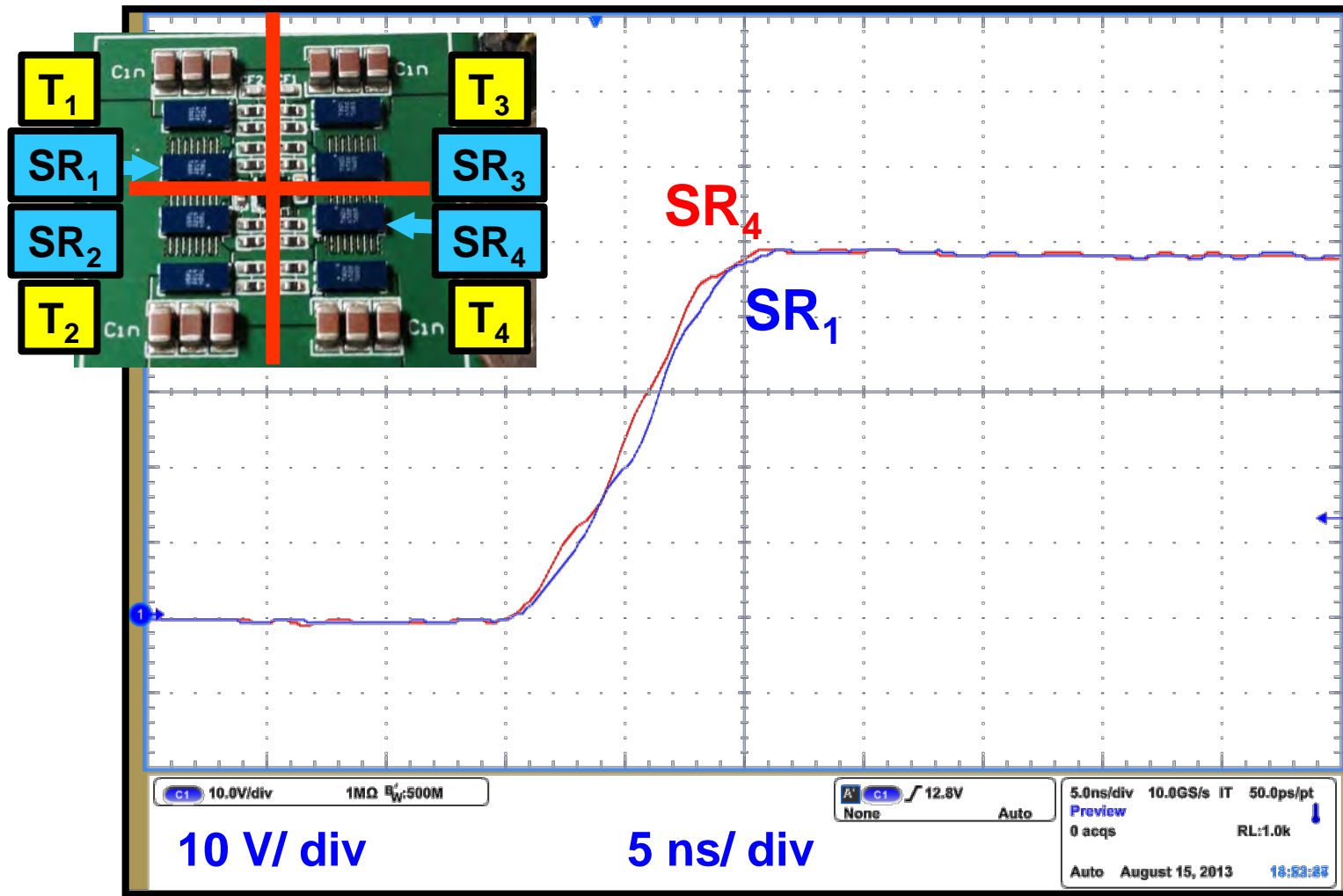




$V_{IN} = 48$ V $I_{OUT} = 25$ A eGaN FET T/SR: 100 V EPC2001
 Nominal Drain Inductance $L_D = L_{LOOP} - L_S = 0.3$ nH

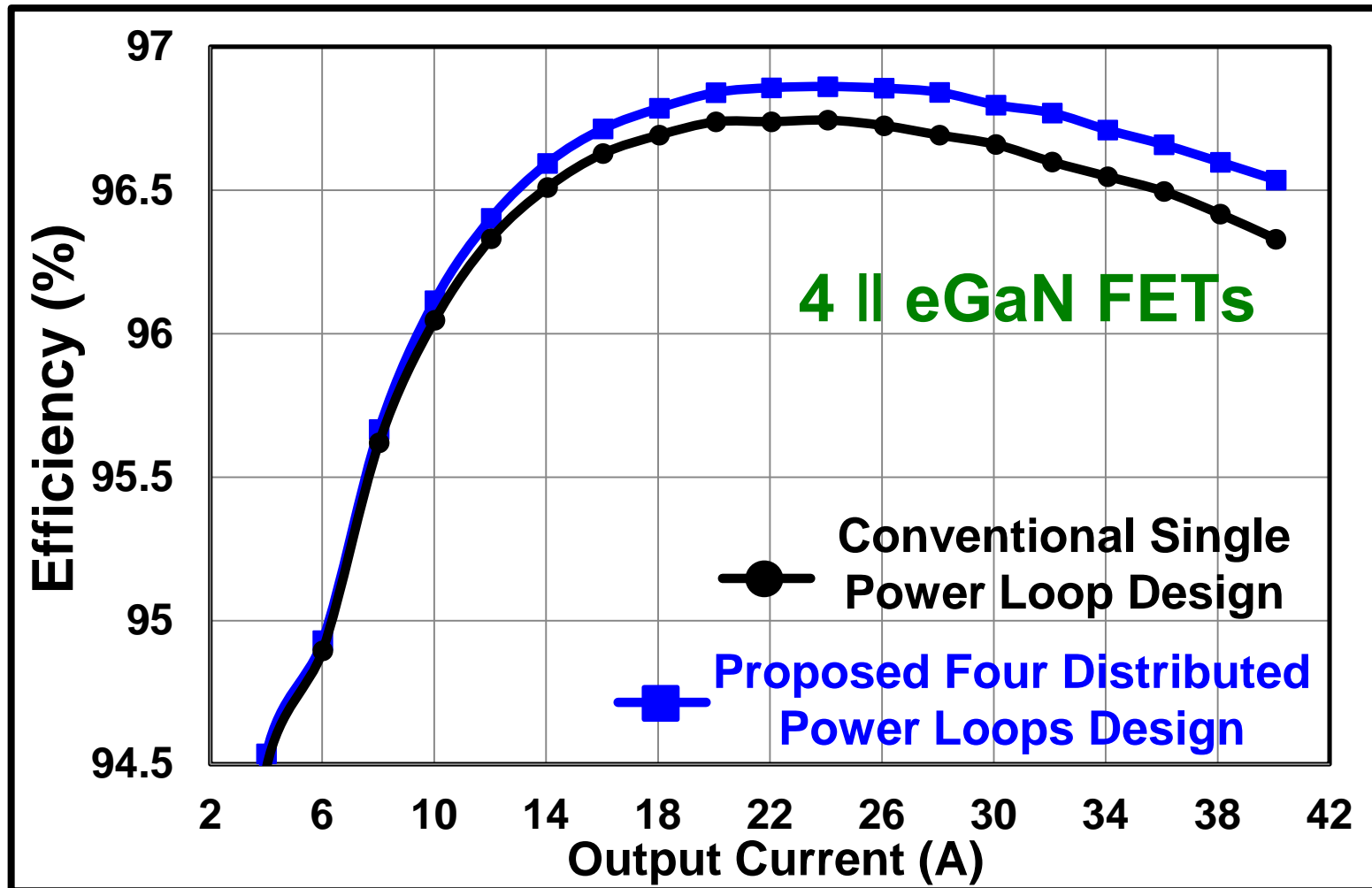


$V_{IN}=48\text{ V}$ $V_{OUT}=12\text{ V}$ $I_{OUT}=30\text{ A}$ $f_{sw}=300\text{ kHz}$ $L=3.3\ \mu\text{H}$ GaN FET T/SR: 100 V EPC2001

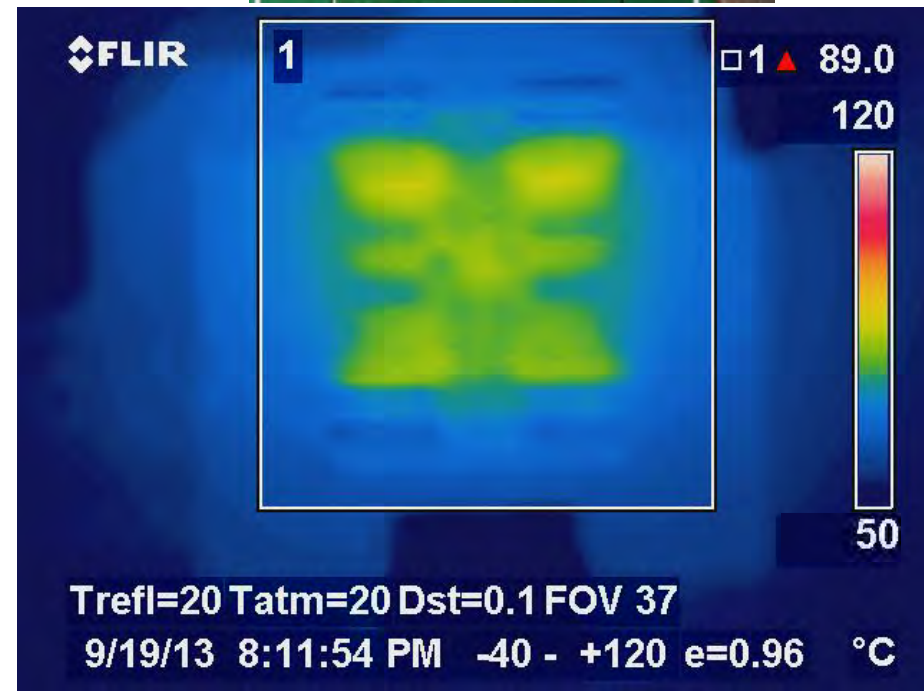
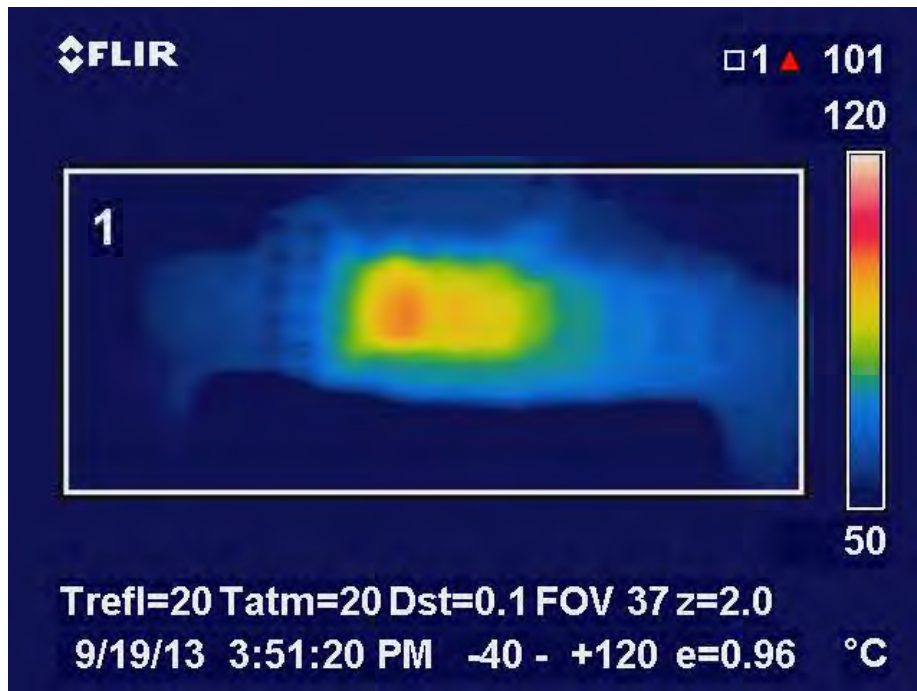
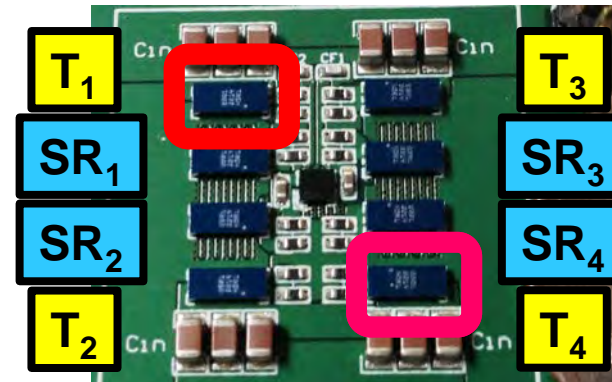
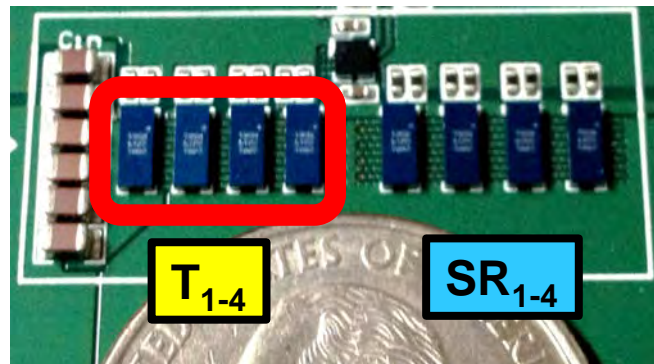


$V_{IN}=48\text{ V}$ $V_{OUT}=12\text{ V}$ $I_{OUT}=30\text{ A}$ $f_{sw}=300\text{ kHz}$ $L=3.3\ \mu\text{H}$ GaN FET T/SR: 100 V EPC2001

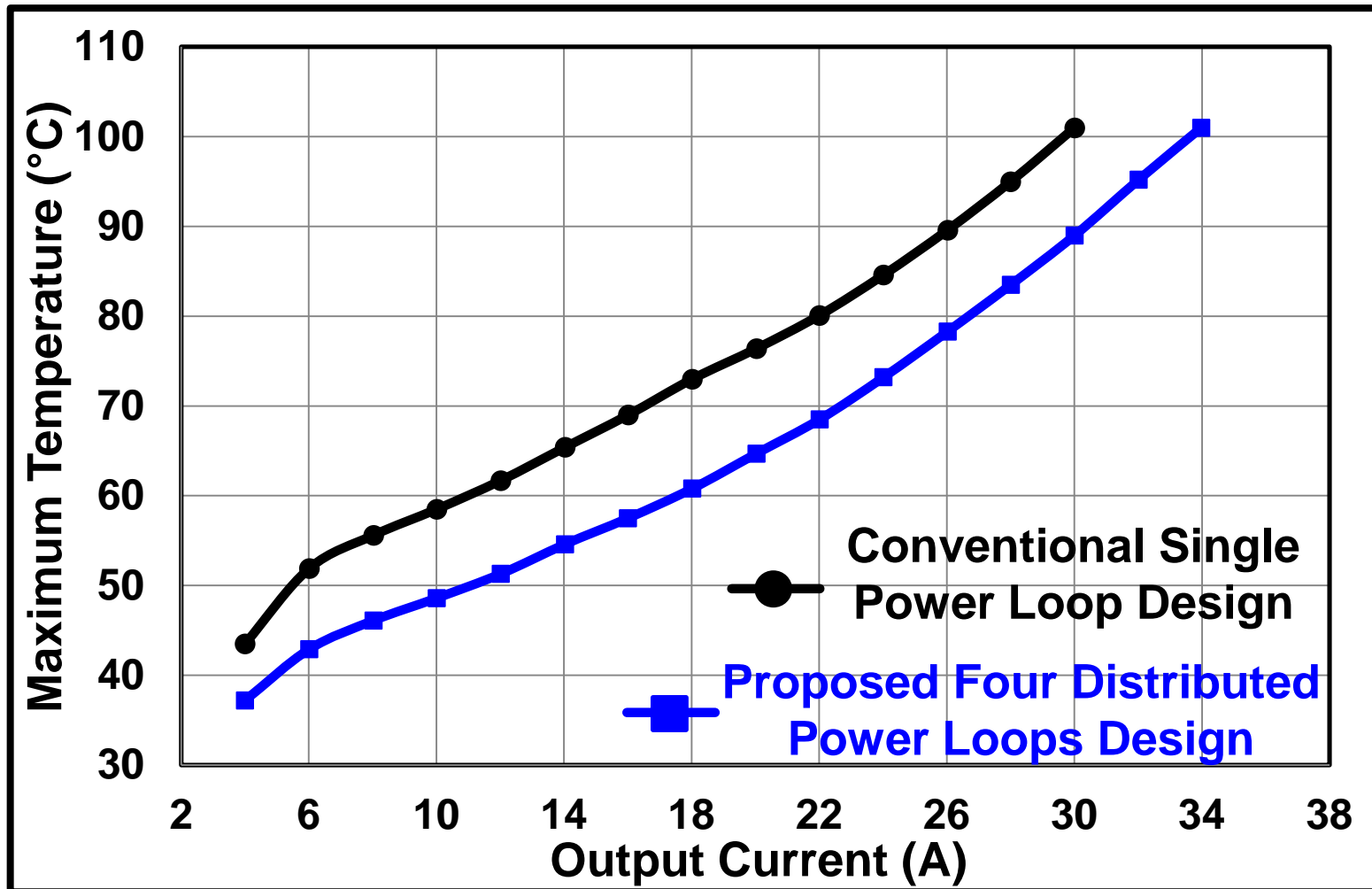
Reference: D. Reusch, J. Strydom, "Effectively Paralleling Gallium Nitride Transistors for High Current and High Frequency Applications," APEC 2015



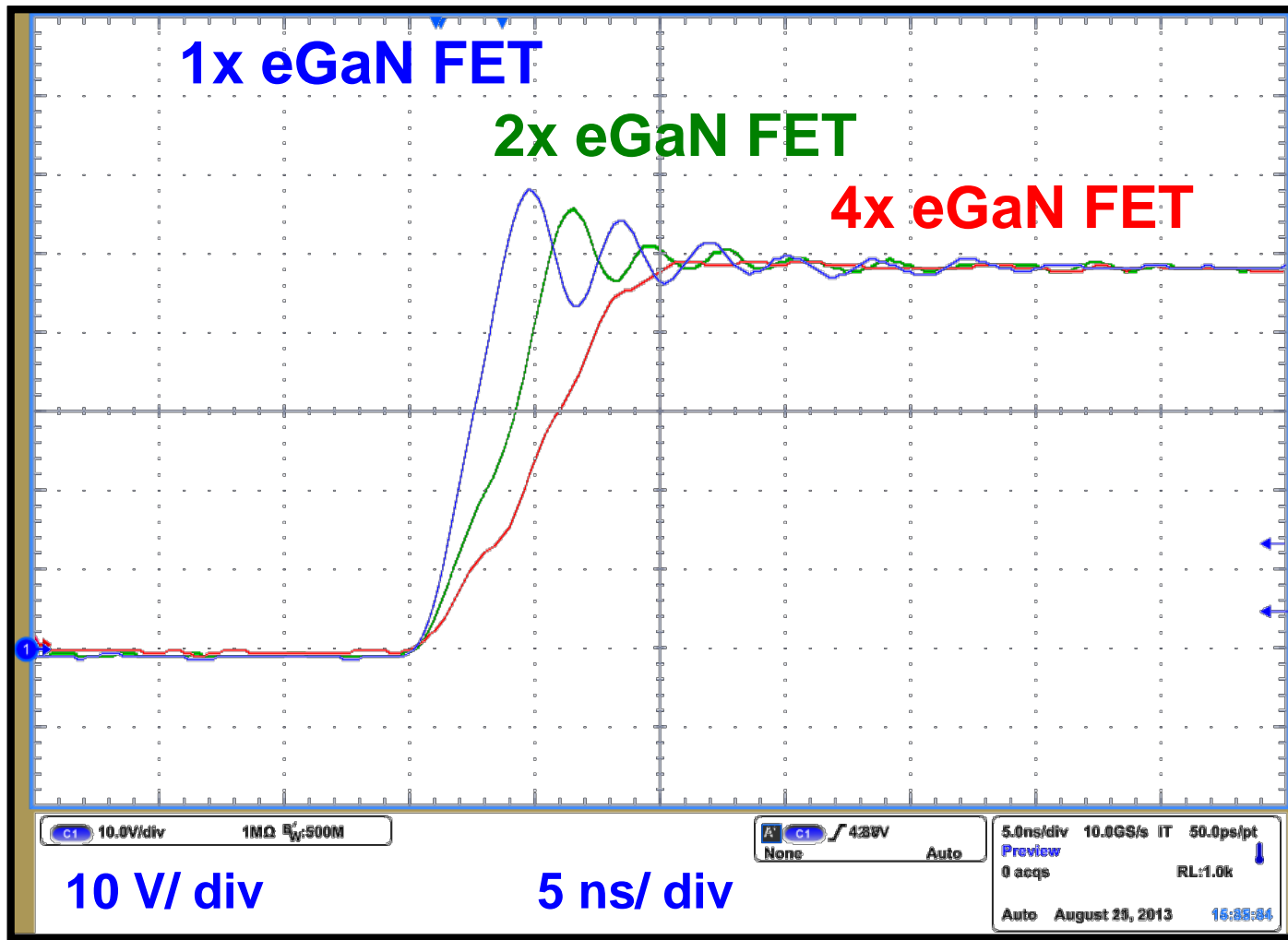
$V_{IN}=48\text{ V}$ $V_{OUT}=12\text{ V}$ $f_{sw}=300\text{ kHz}$ $L=3.3\ \mu\text{H}$ GaN FET T/SR: 4x100 V EPC2001
4 Layer 2 oz PCB



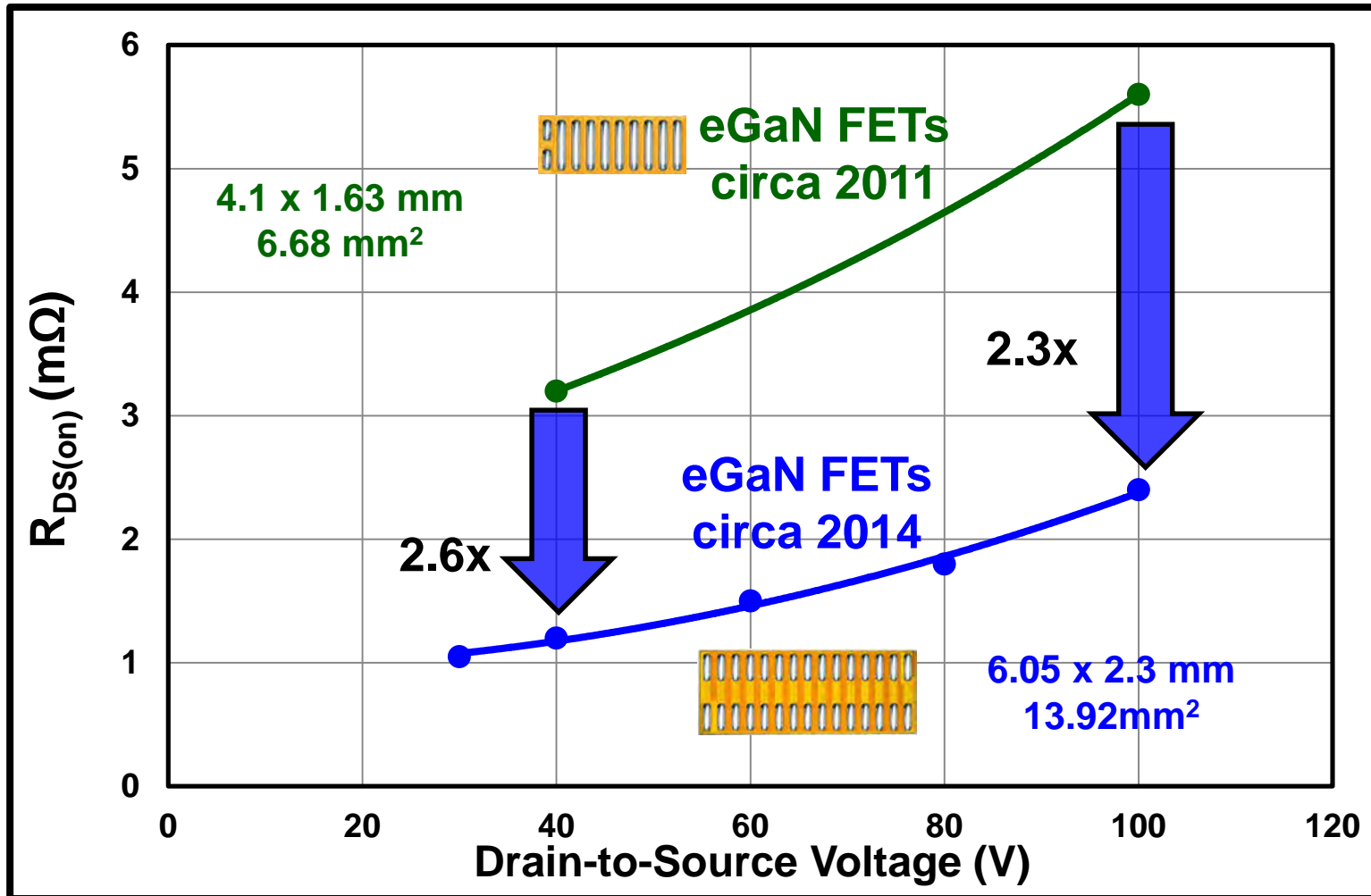
$V_{IN}=48\text{ V}$ $V_{OUT}=12\text{ V}$ $I_{OUT}=30\text{ A}$ $f_{sw}=300\text{ kHz}$ $L=3.3\text{ }\mu\text{H}$ GaN FET T/SR: 100 V EPC2001



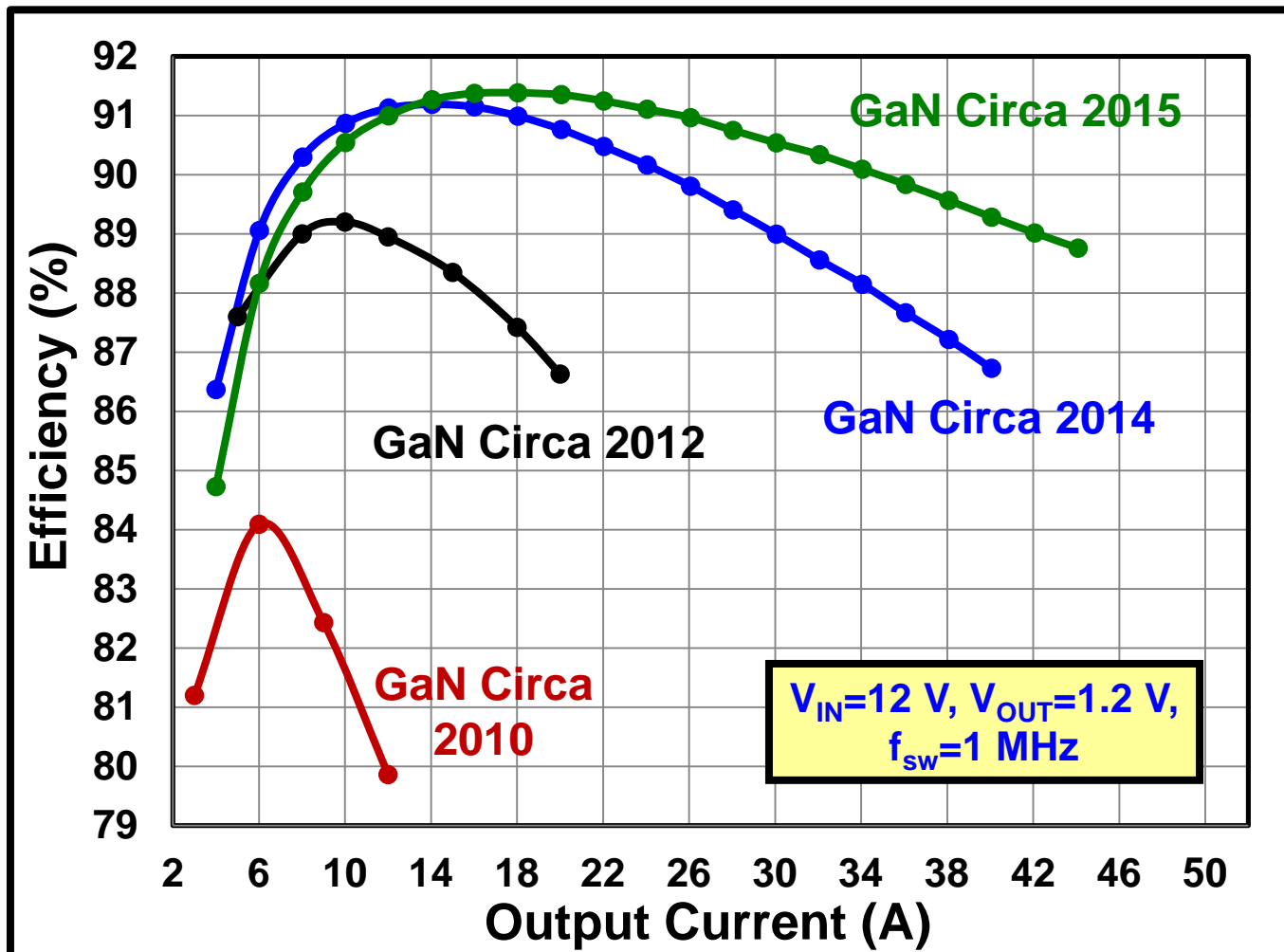
$V_{IN}=48\text{ V}$ $V_{OUT}=12\text{ V}$ $f_{sw}=300\text{ kHz}$ $L=3.3\ \mu\text{H}$ GaN FET T/SR: 100 V EPC2001
Fan Speed 200 LFM 4 Layer 2 oz PCB



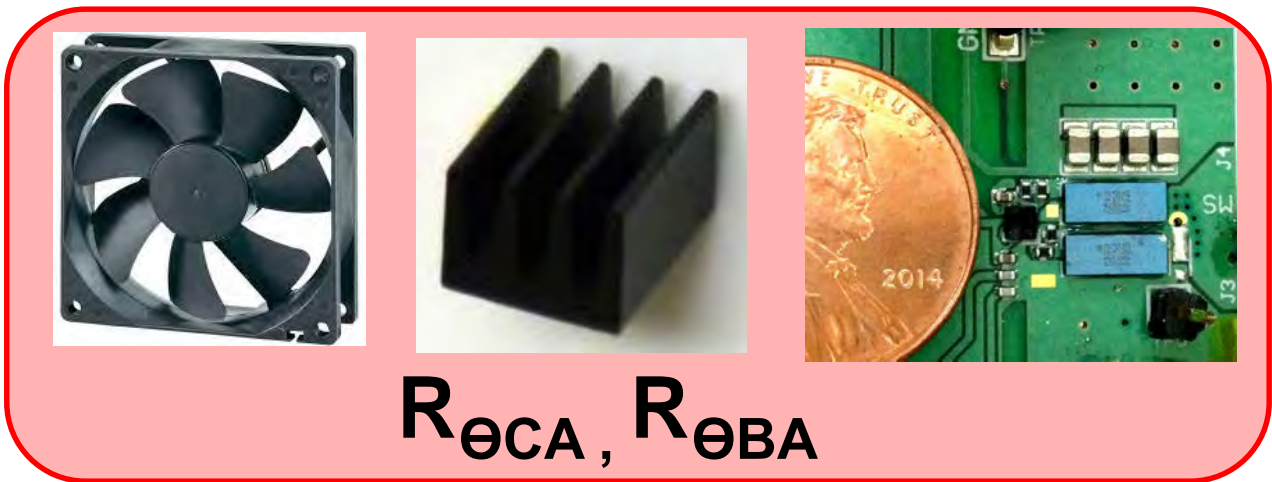
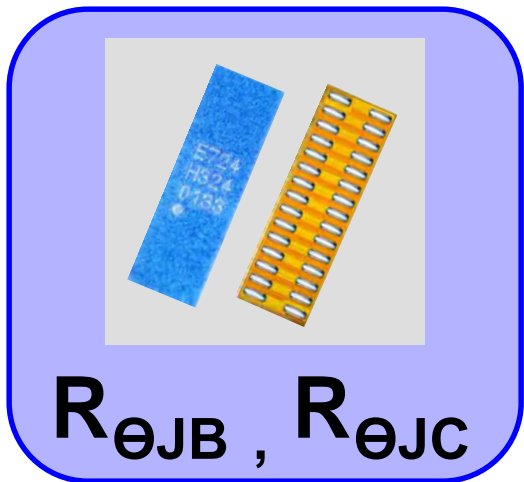
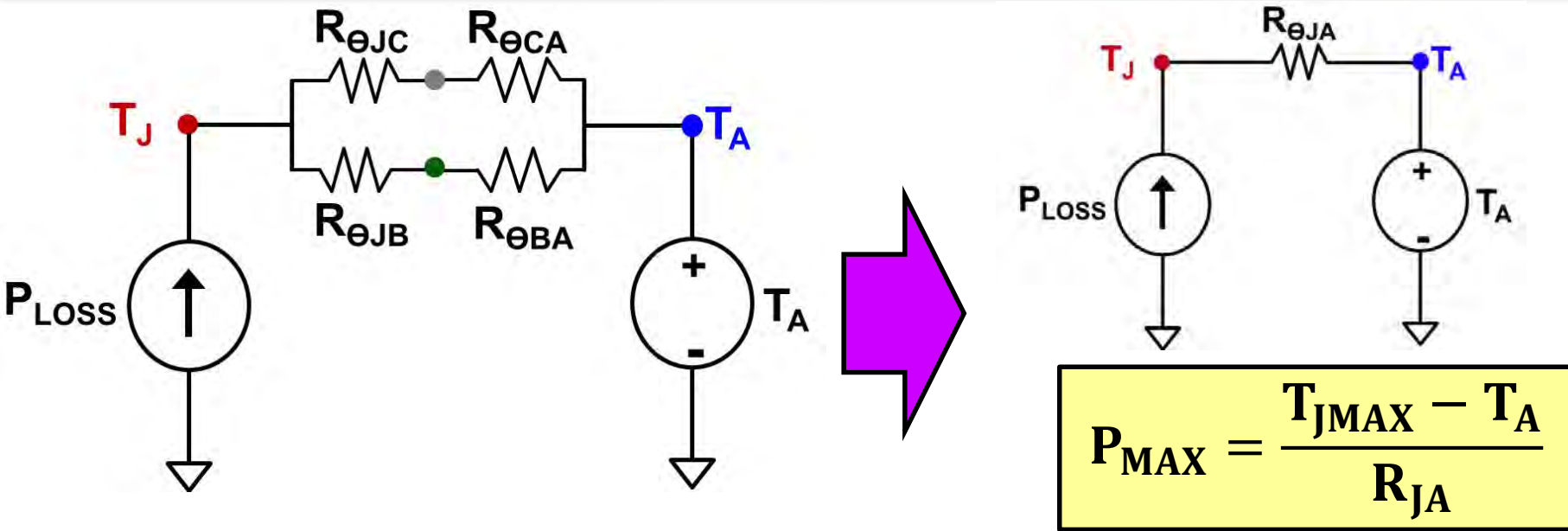
$V_{IN}=48\text{ V}$ $V_{OUT}=12\text{ V}$ $I_{OUT}=30\text{ A}$ / number of devices $f_{sw}=300\text{ kHz}$ GaN FET T/SR: 100 V EPC2001

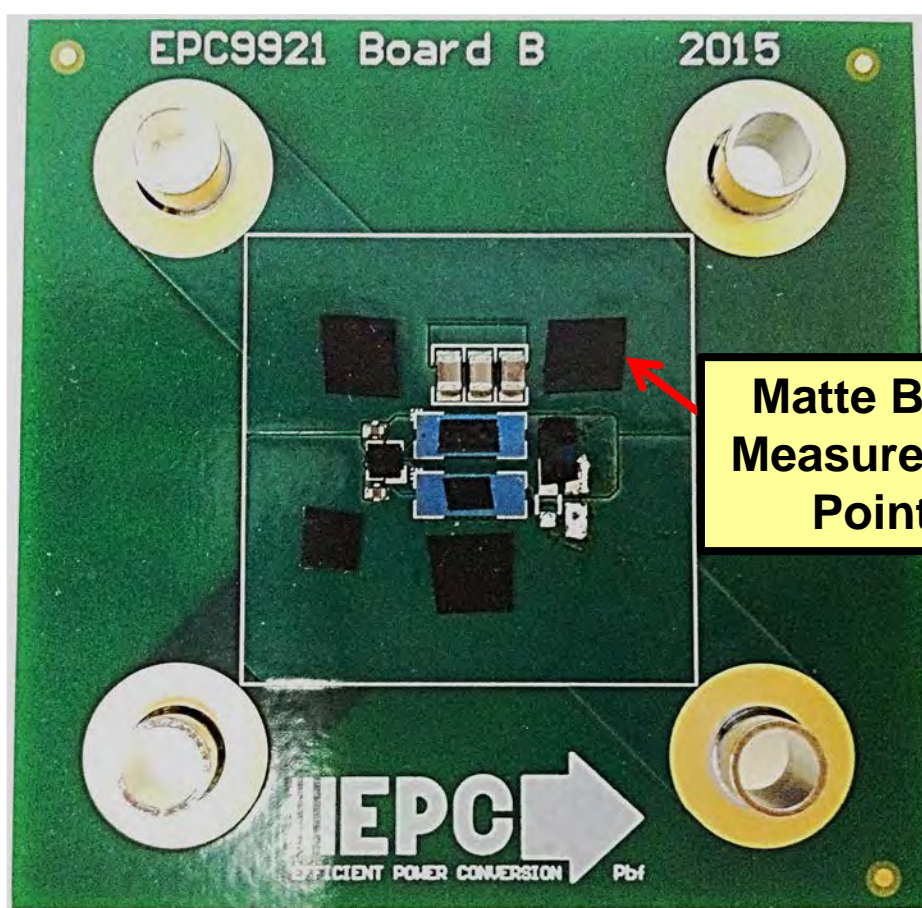


$V_{GS} = 5 \text{ V}$

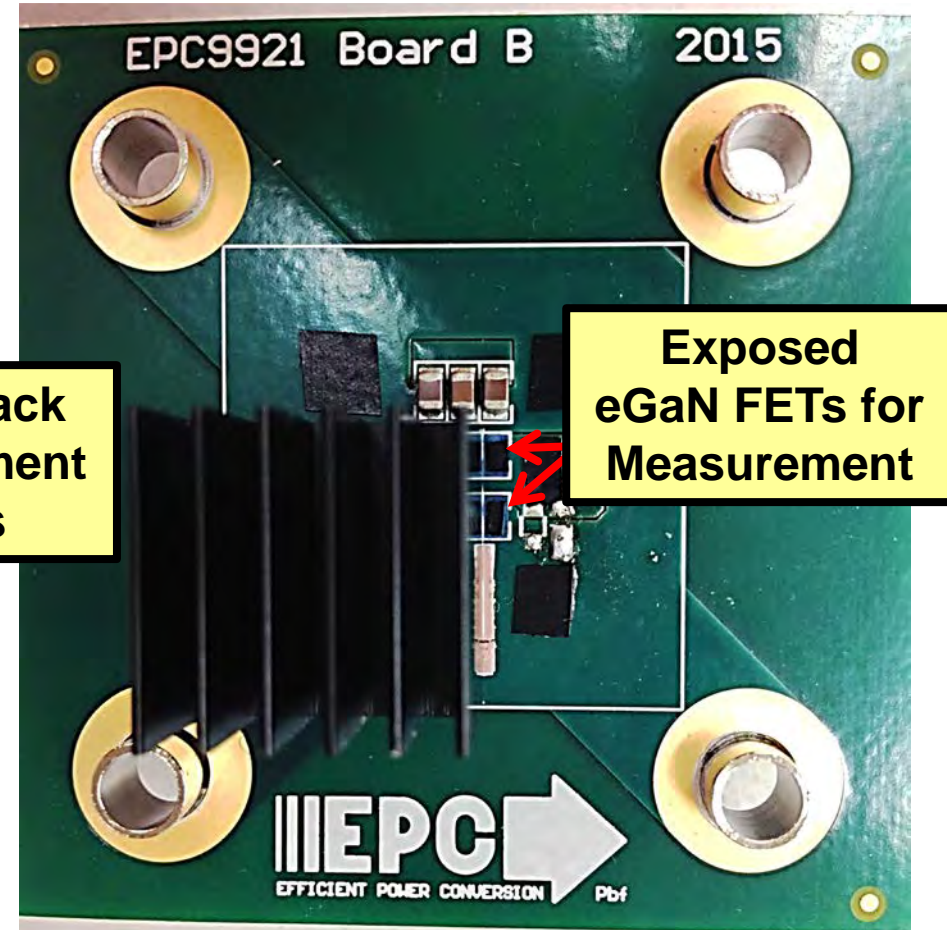


Thermal

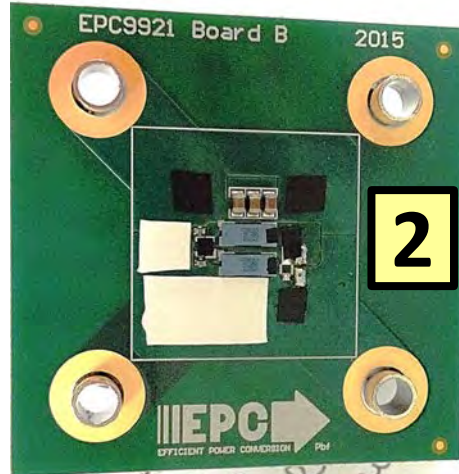
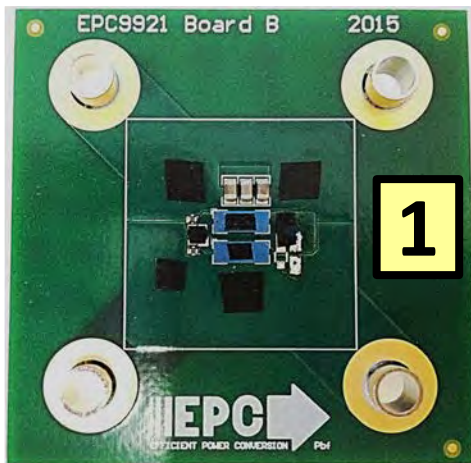




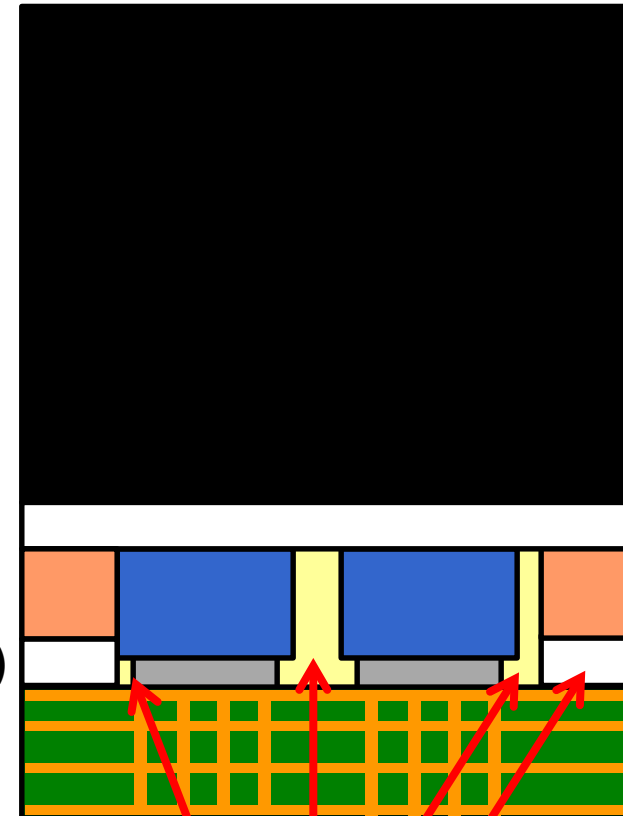
**1x1 inch Buck Converter
4 Layers 2oz Copper**



**15x15x14.5 mm
Heat Sink**



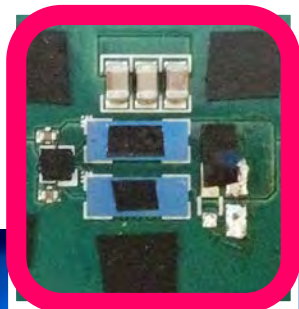
Heat Sink (4)



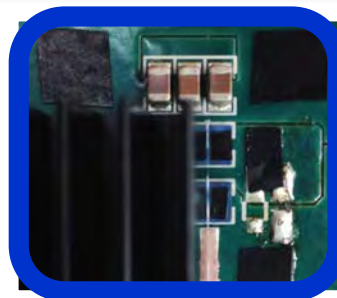
Thermal Tape (4)
Gap Pad (3)
Thermal Tape (2)
PCB (1)

TIM (Optional)



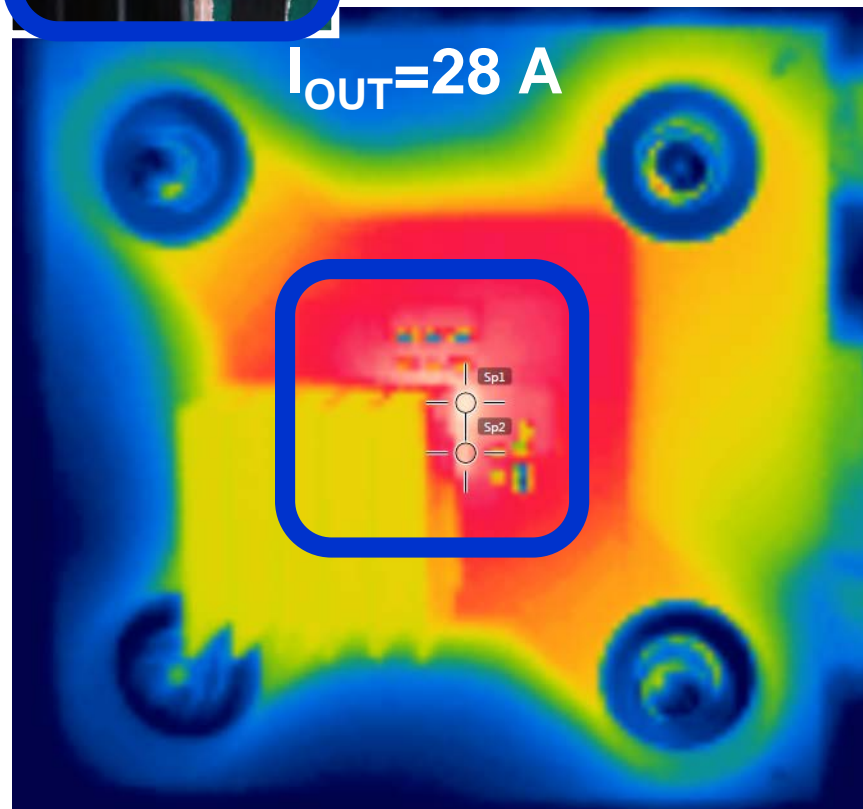
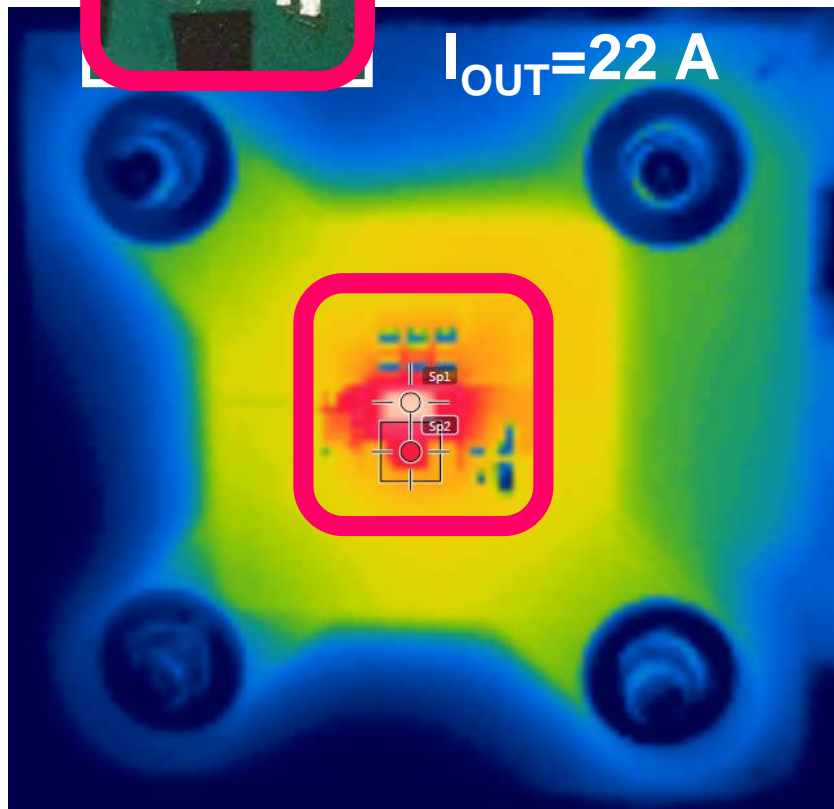


Q1 $\approx 98^{\circ}\text{C}$
Q2 $\approx 84^{\circ}\text{C}$



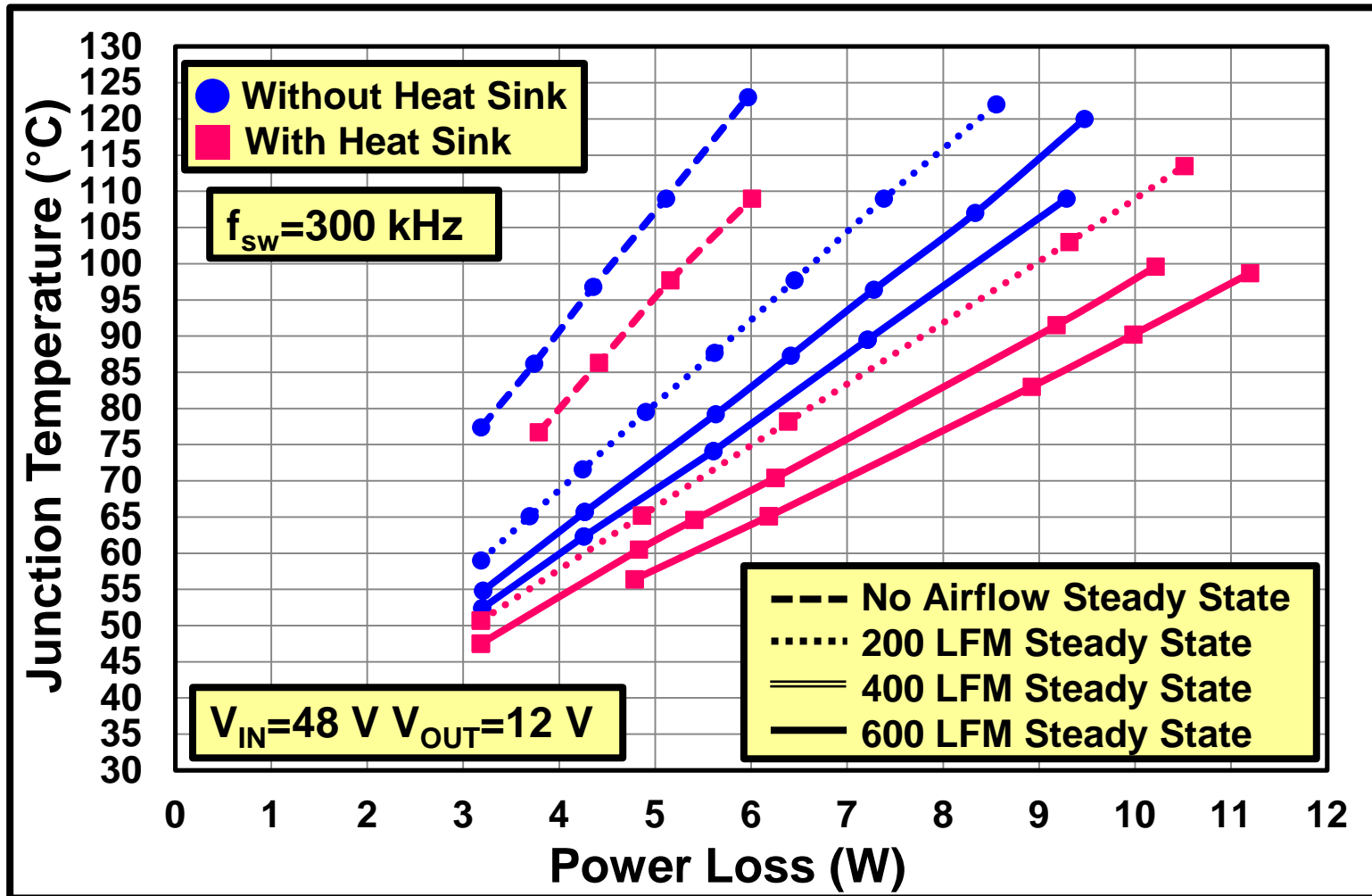
Q1 $\approx 102^{\circ}\text{C}$
Q2 $\approx 92^{\circ}\text{C}$

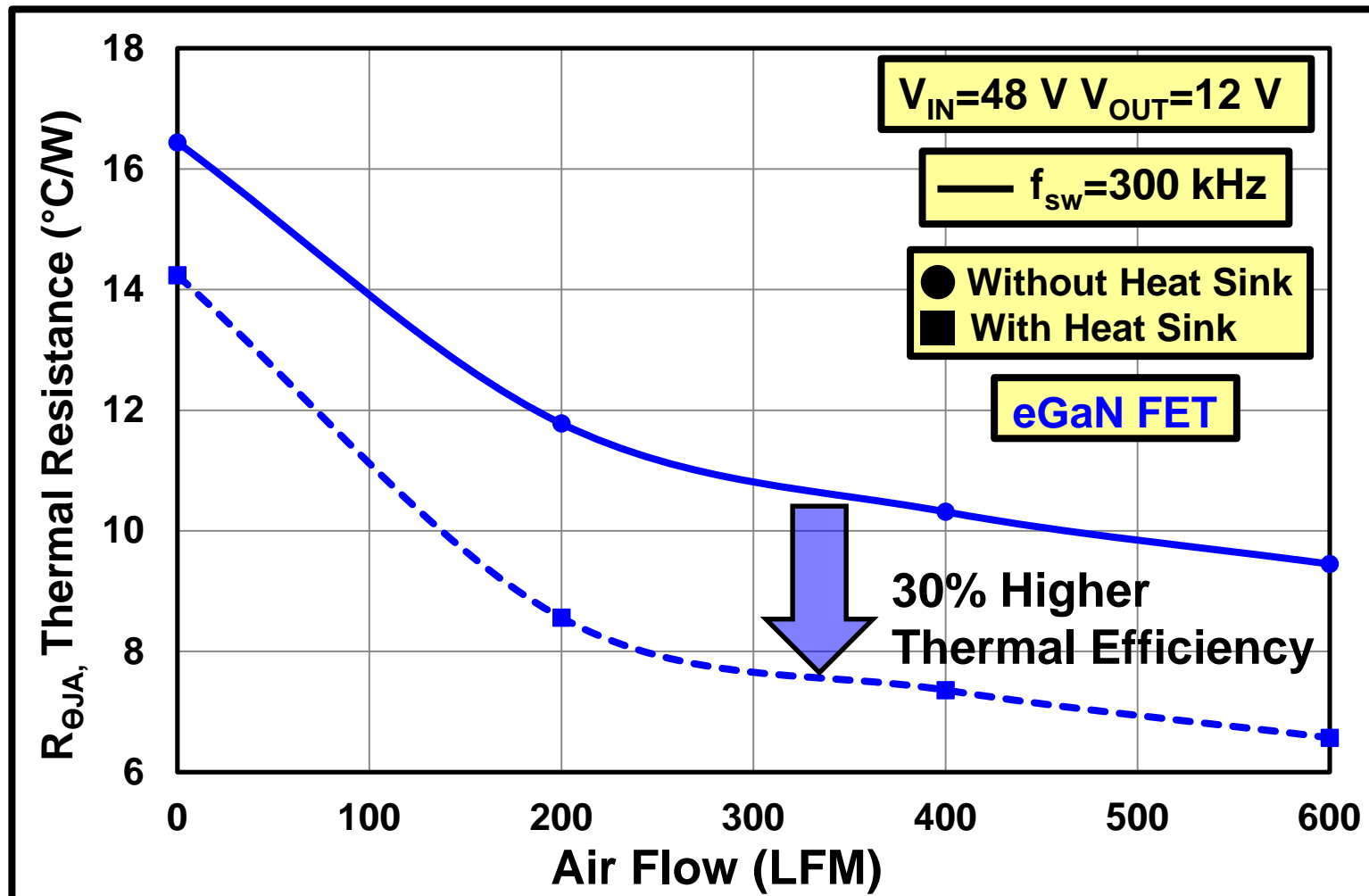
100°C



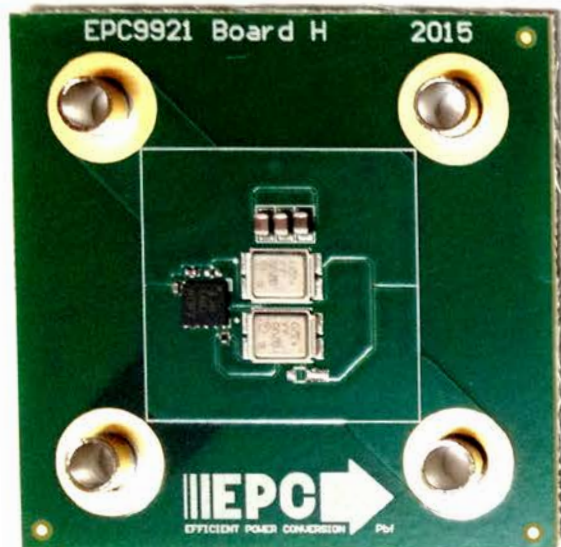
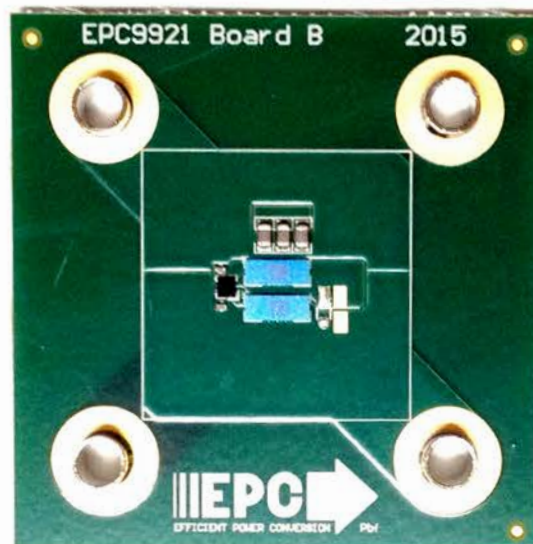
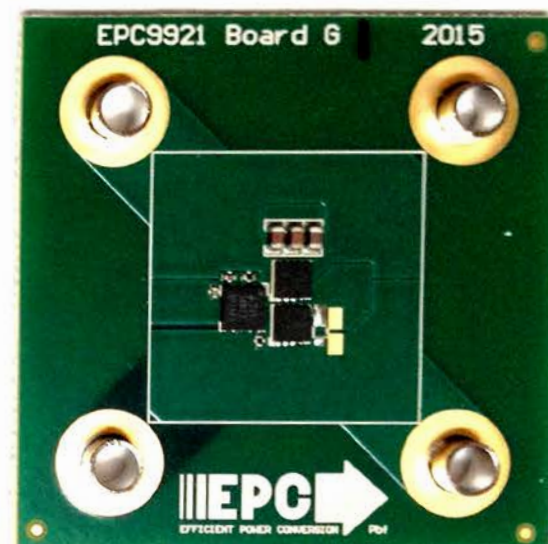
25°C

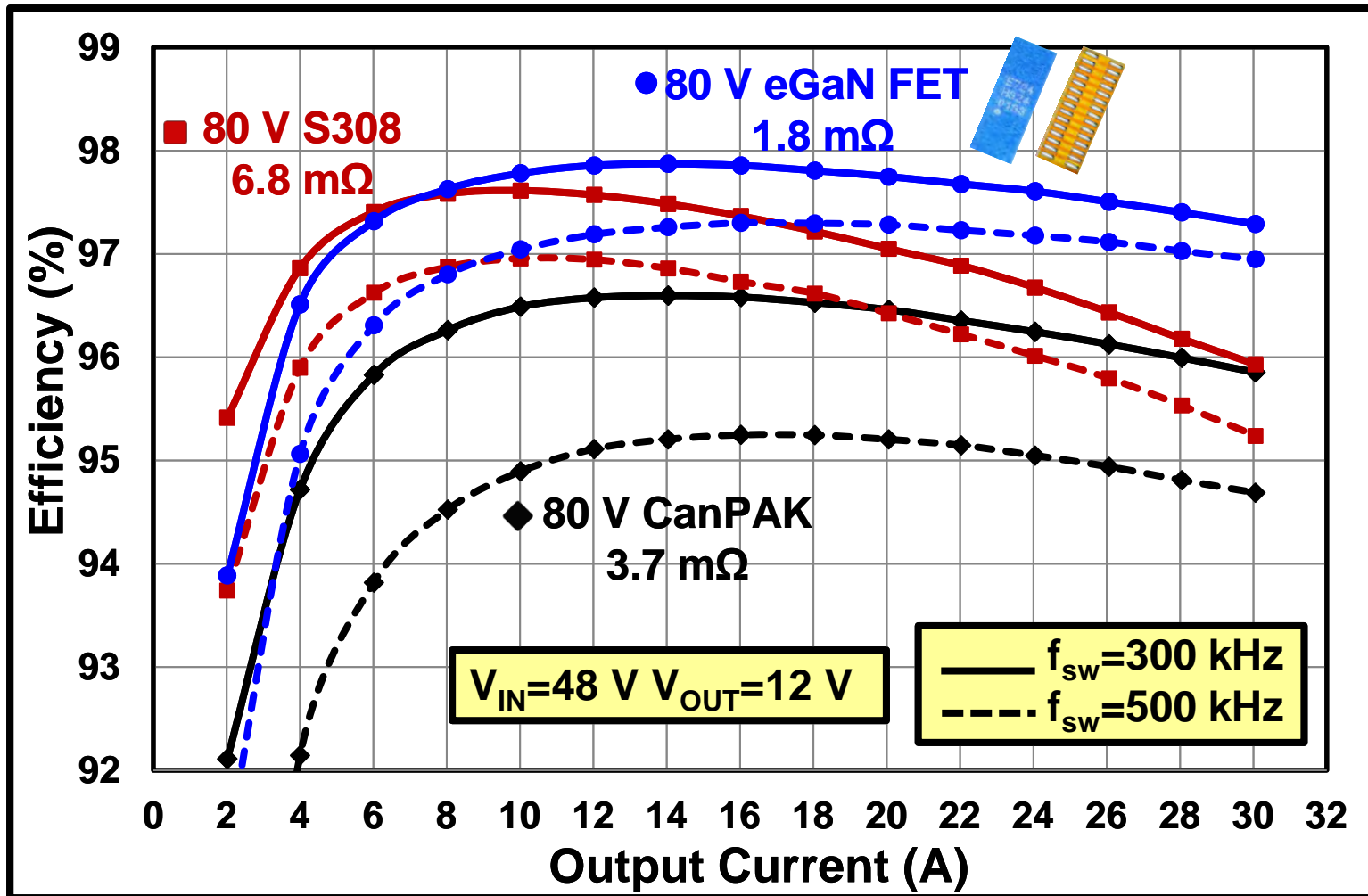
Devices 80 V EPC2021 Fan Speed=200 LFM $V_{IN}=48\text{ V}$ $V_{OUT}=12\text{ V}$ $f_{sw}=300\text{ kHz}$ $L=4.7\text{ }\mu\text{H}$

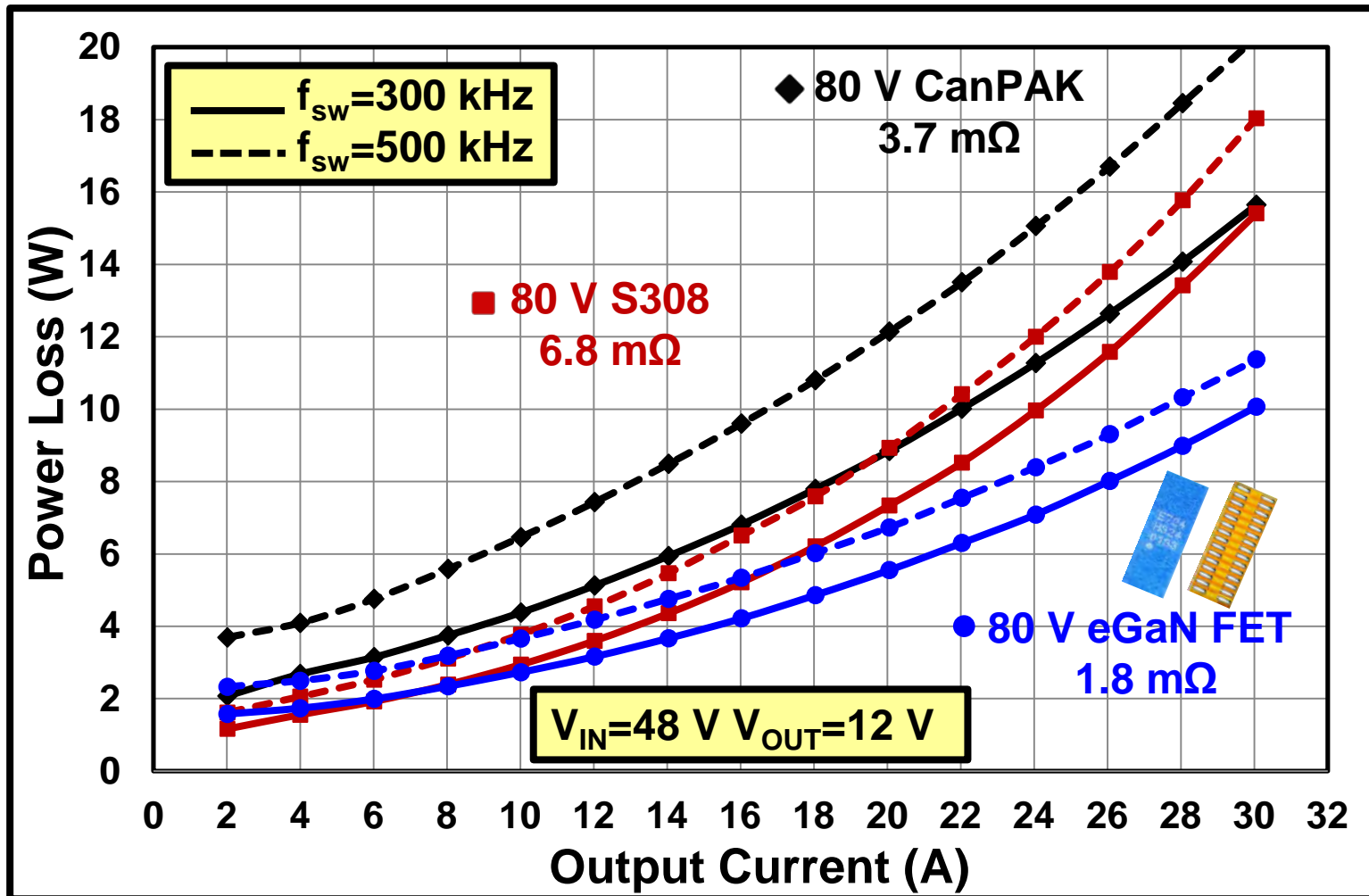


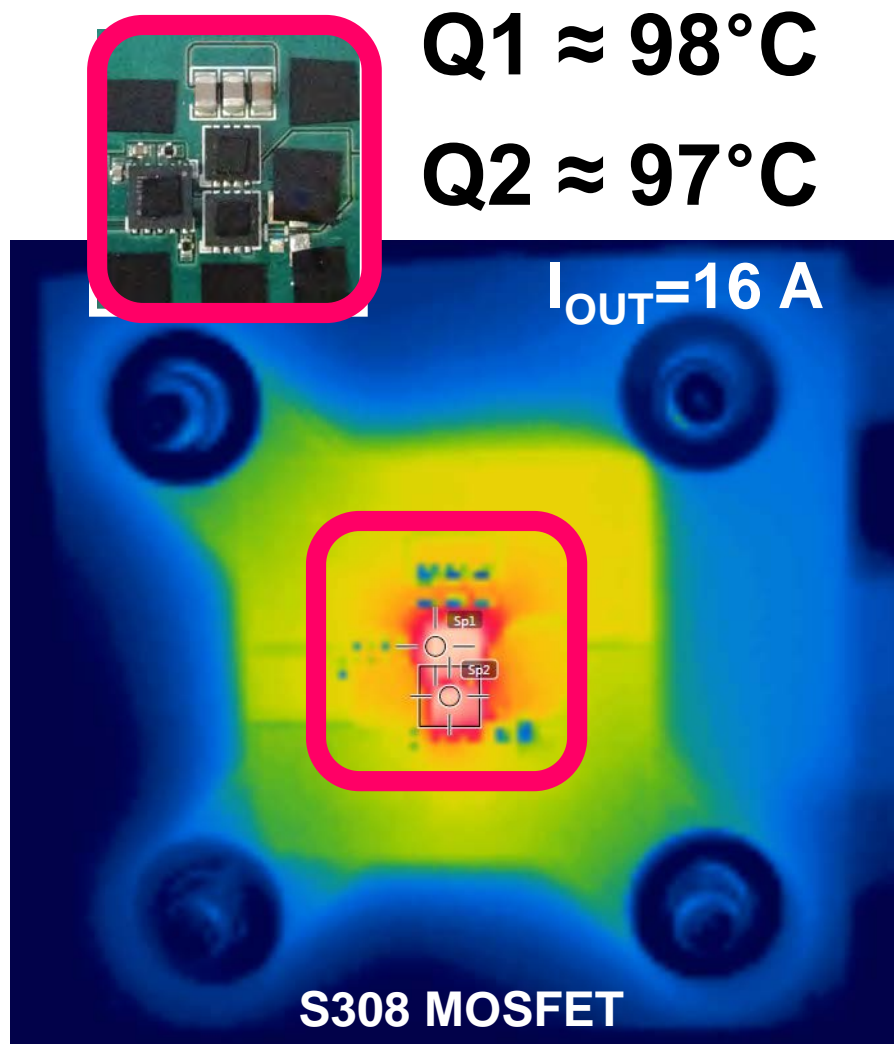
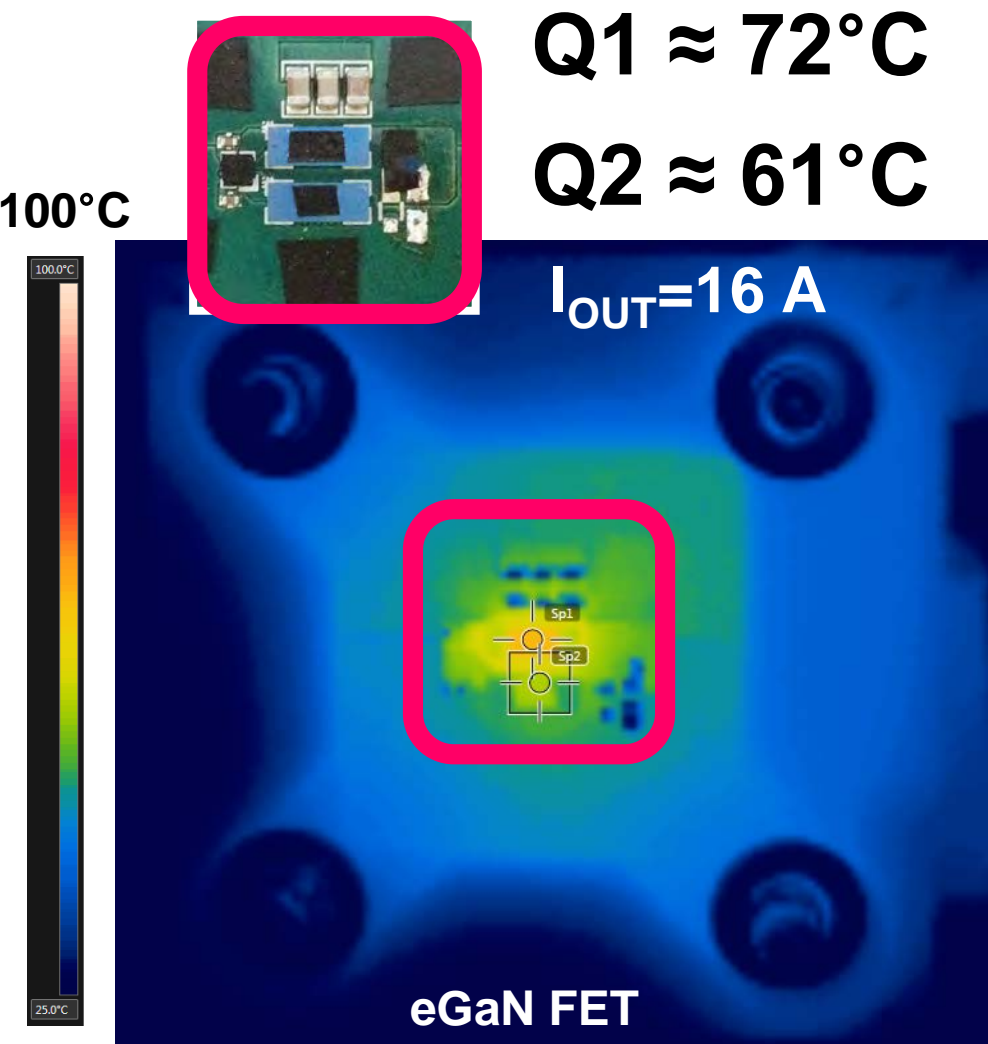


48 V Non-Isolated Buck Converter

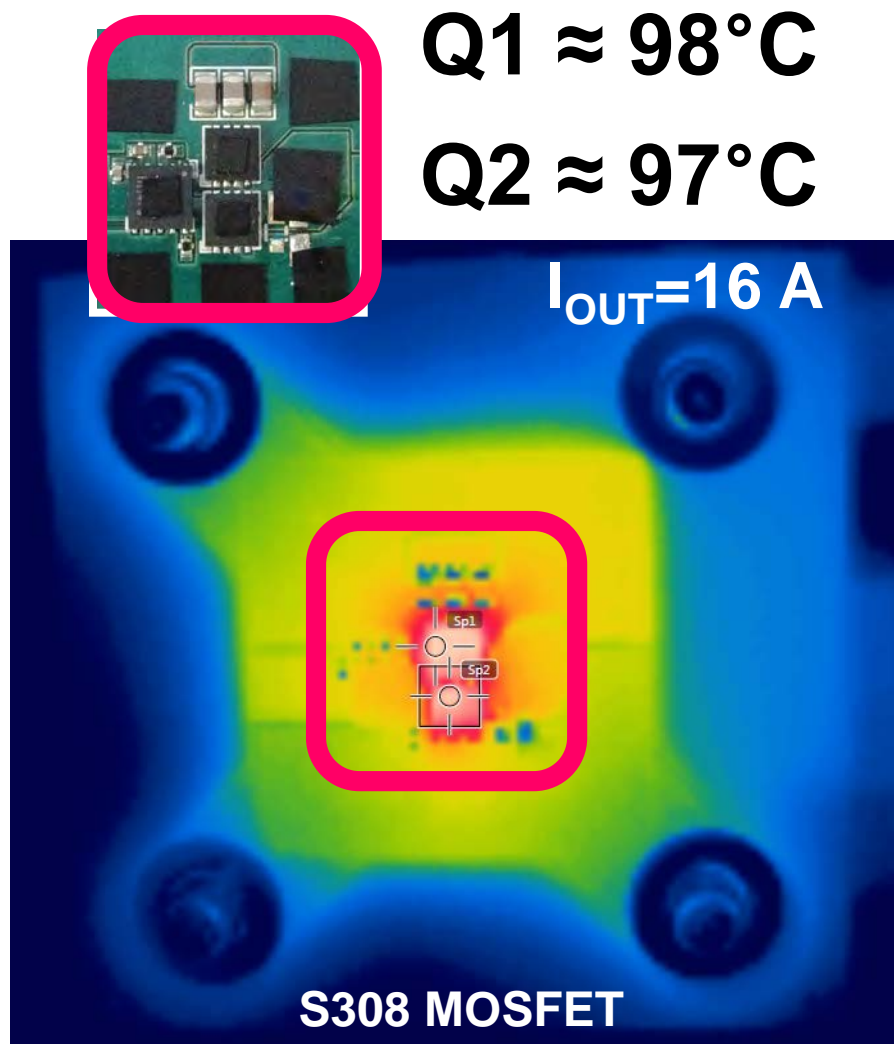
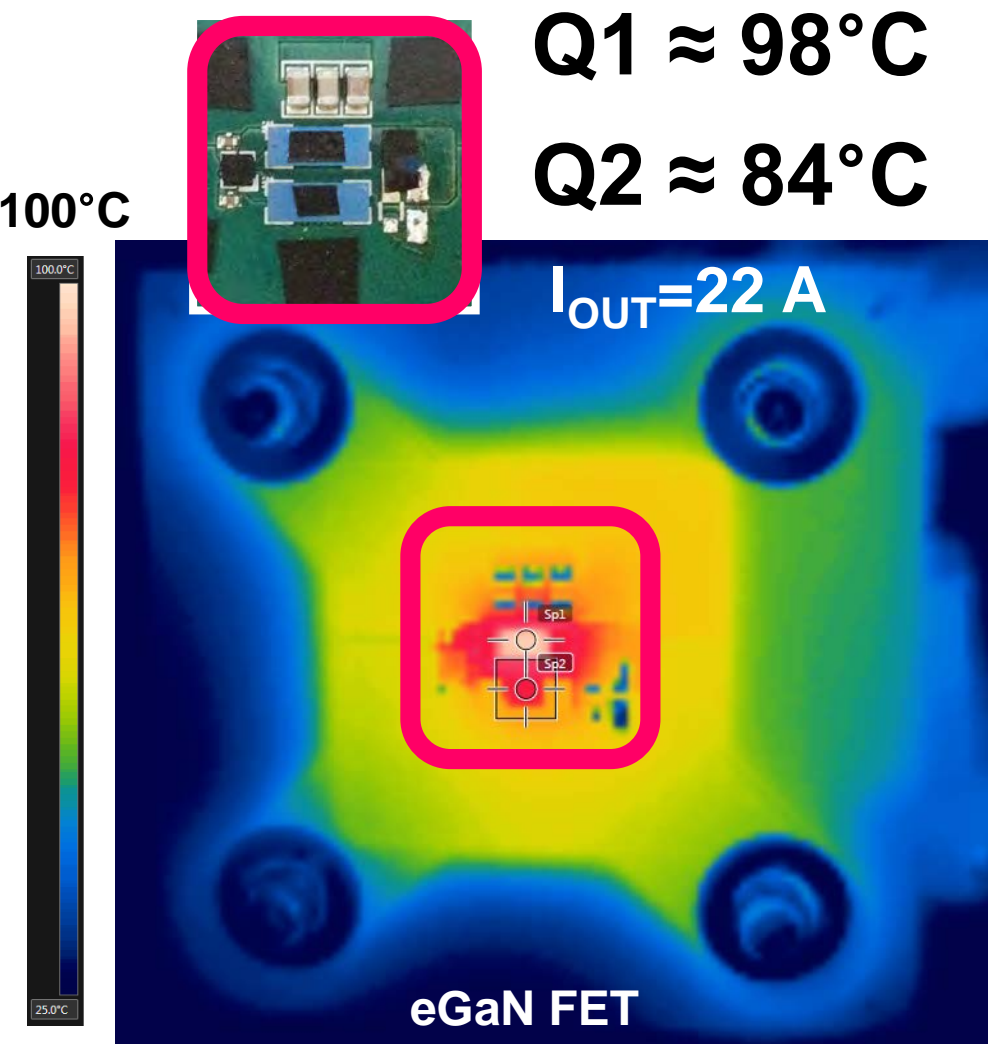
80 V 3.7 mΩ**CanPAK MOSFET****80 V 1.8 mΩ****LGA eGaN FET****80 V 6.8 mΩ****S308 MOSFET****Active Area**
≈150 mm²**Active Area**
≈60 mm²**Active Area**
≈132 mm²



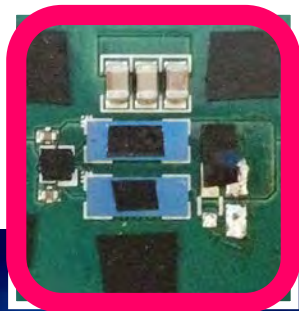




Fan Speed=200 LFM $I_{OUT} = 16$ A $V_{IN} = 48$ V $V_{OUT} = 12$ V $f_{sw} = 300$ kHz $L = 4.7$ μ H



Fan Speed=200 LFM $V_{IN} = 48$ V $V_{OUT} = 12$ V $f_{sw} = 300$ kHz $L = 4.7$ μ H



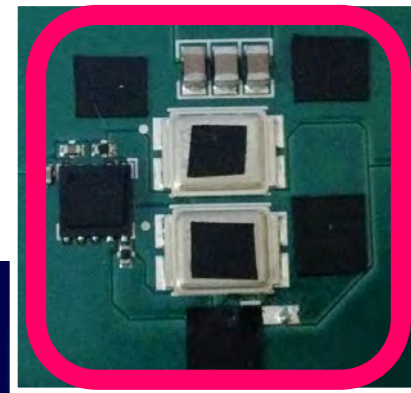
Q1 ≈ 65°C

Q2 ≈ 55°C

I_{OUT}=14 A



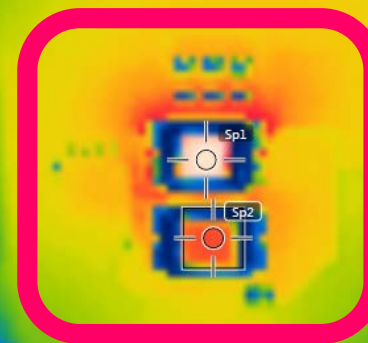
eGaN FET



Q1 ≈ 100°C

Q2 ≈ 80°C

I_{OUT}=14 A



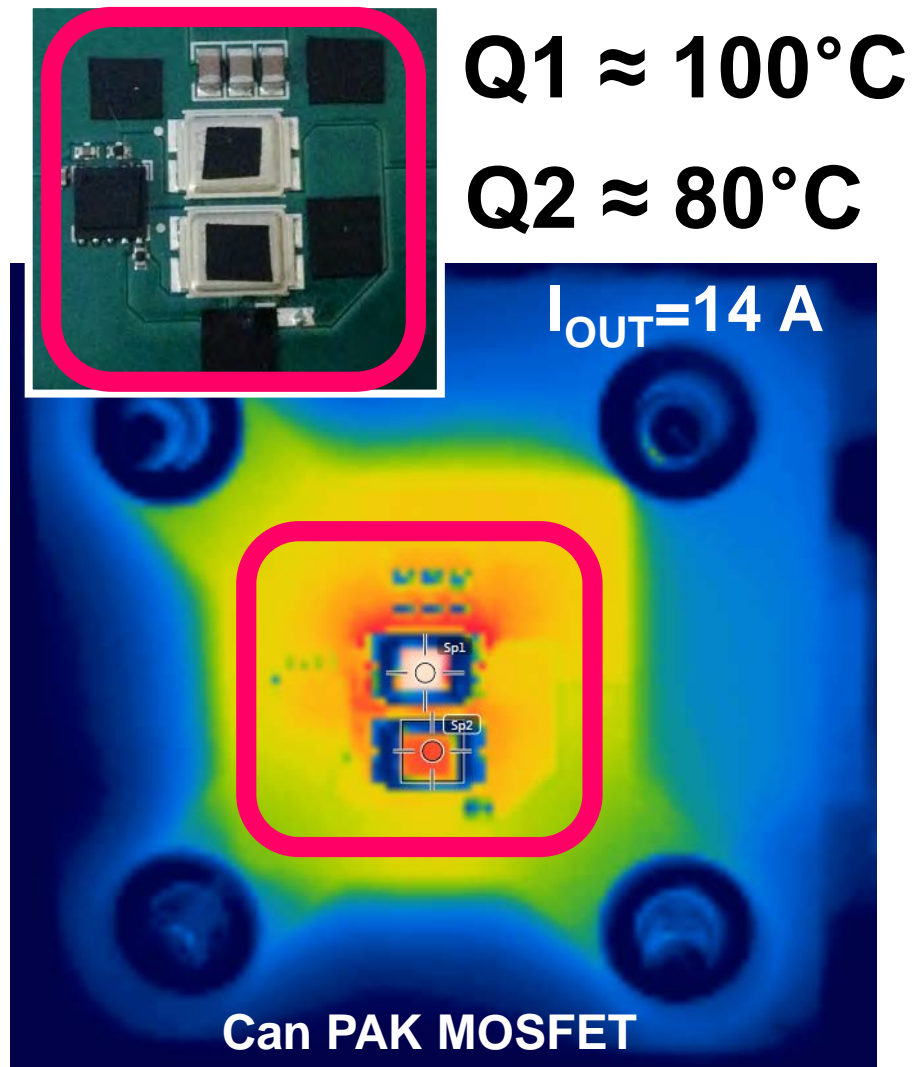
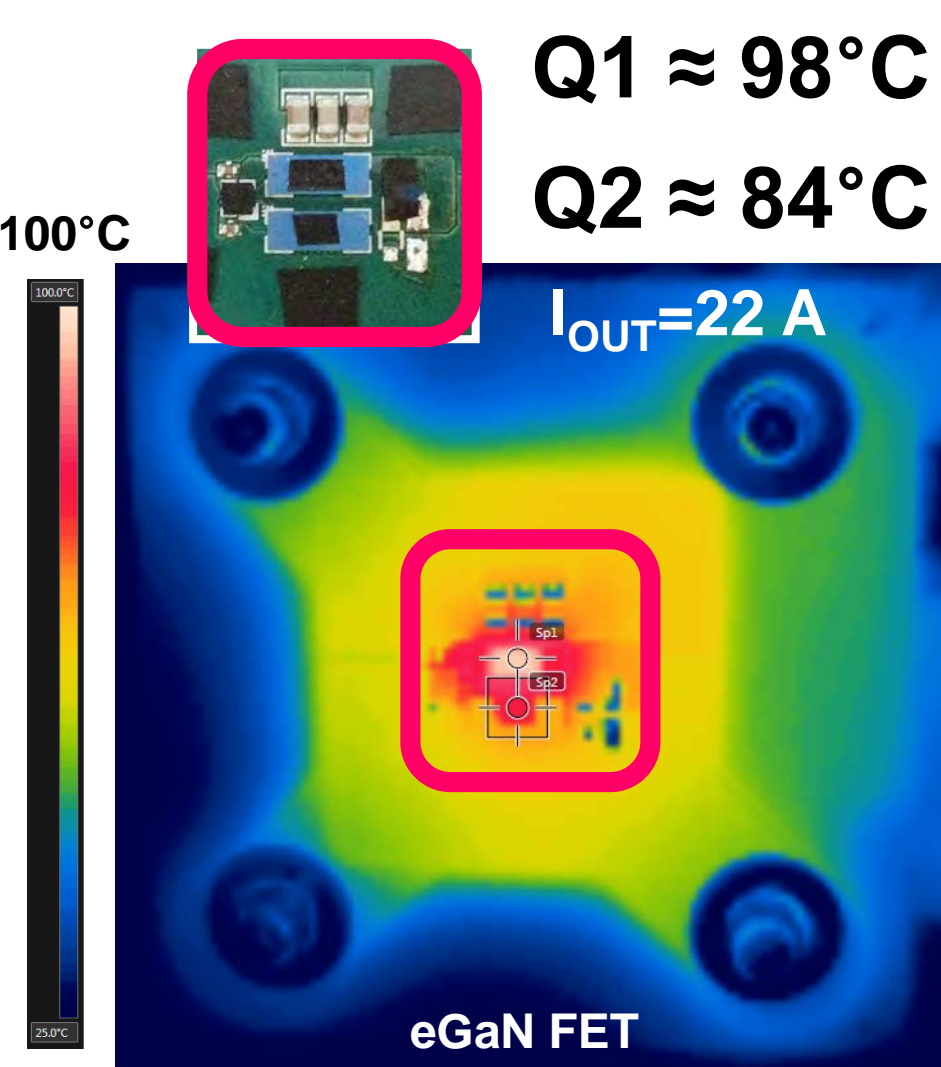
Can PAK MOSFET

100°C

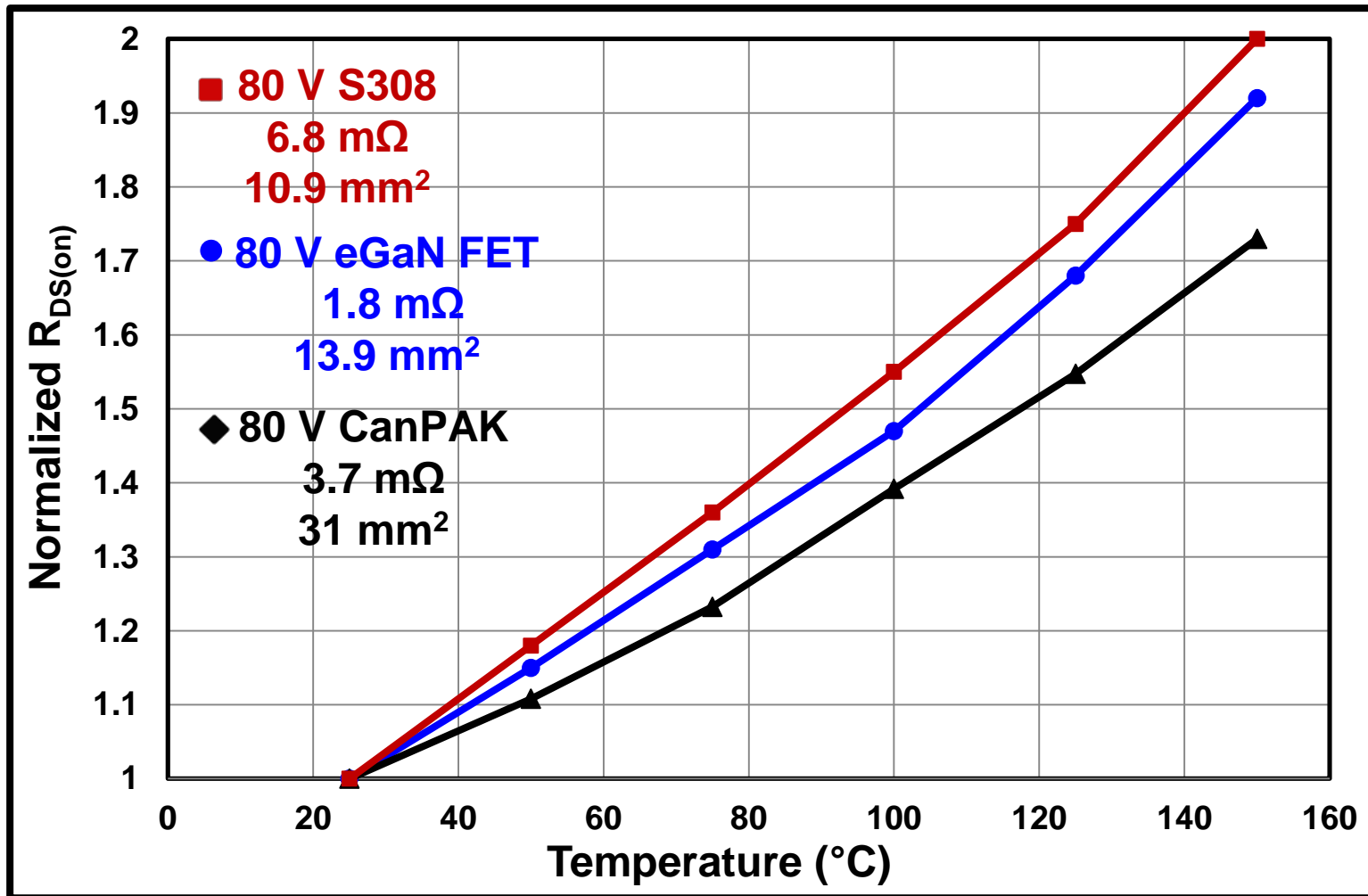


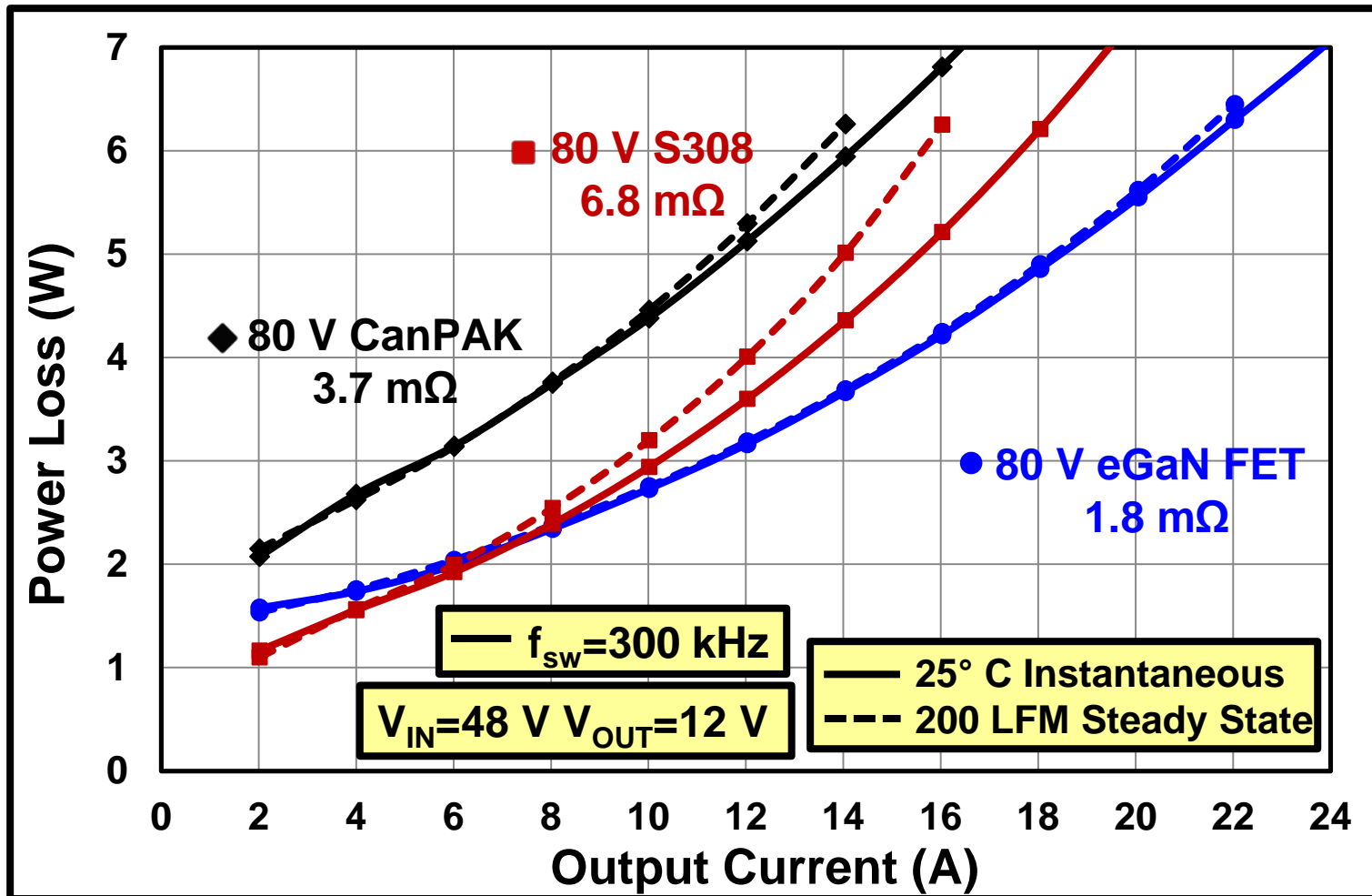
25°C

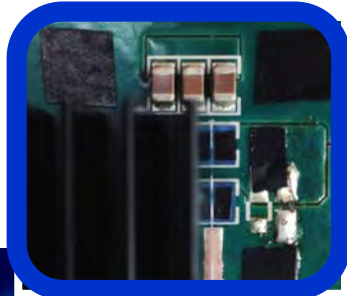
Fan Speed=200 LFM I_{OUT}=14 A V_{IN}=48 V V_{OUT}=12 V f_{sw}=300 kHz L=4.7 μH



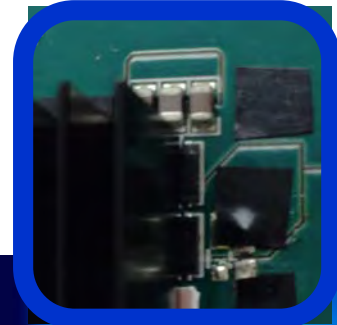
Fan Speed=200 LFM $V_{\text{IN}}=48\text{ V}$ $V_{\text{OUT}}=12\text{ V}$ $f_{\text{sw}}=300\text{ kHz}$ $L=4.7\text{ }\mu\text{H}$





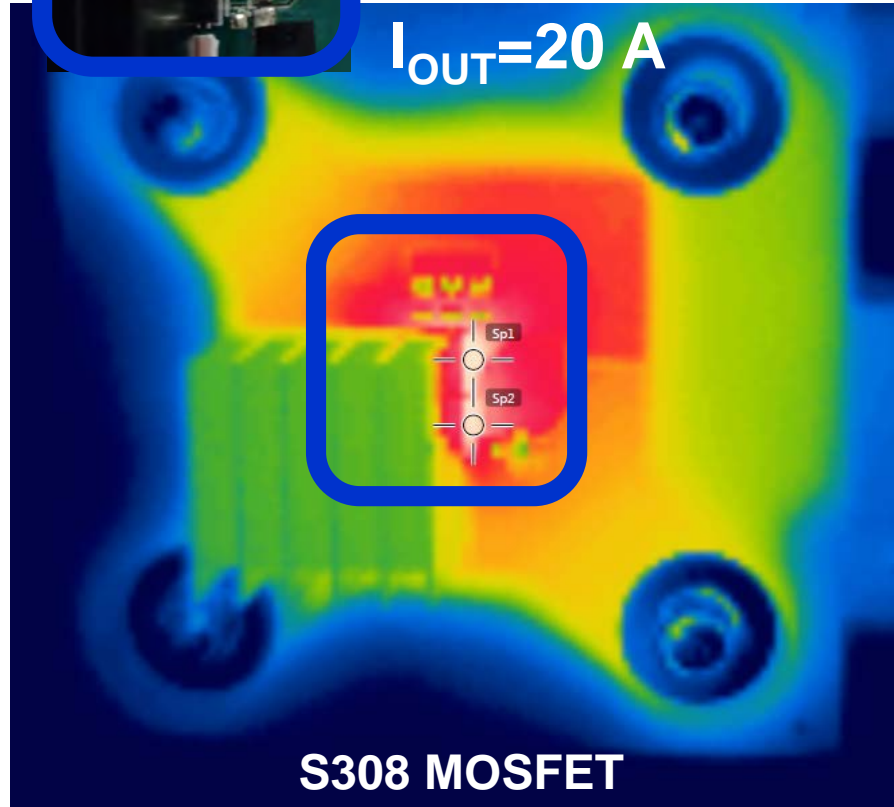
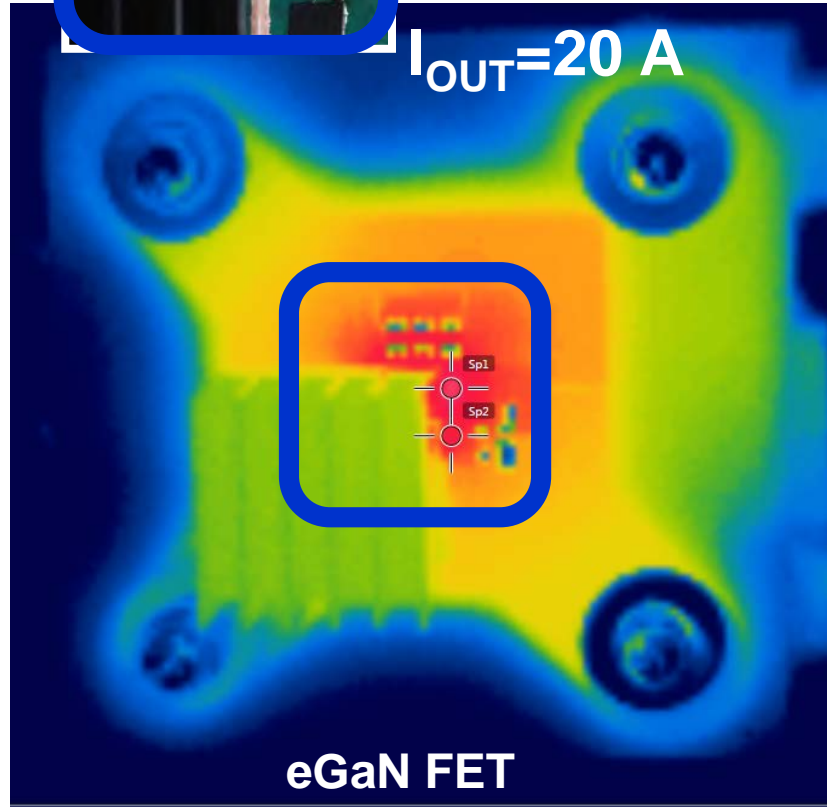


Q1 ≈ 65°C
Q2 ≈ 54°C



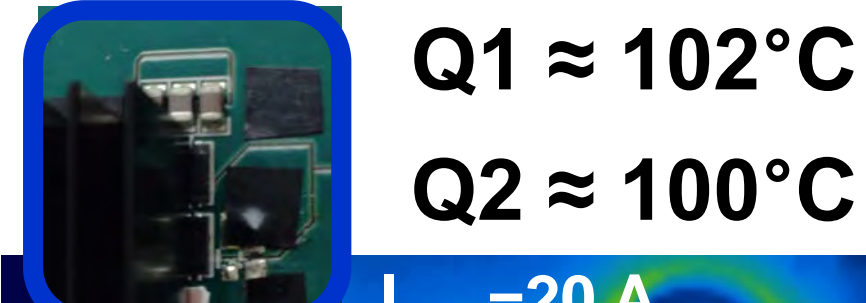
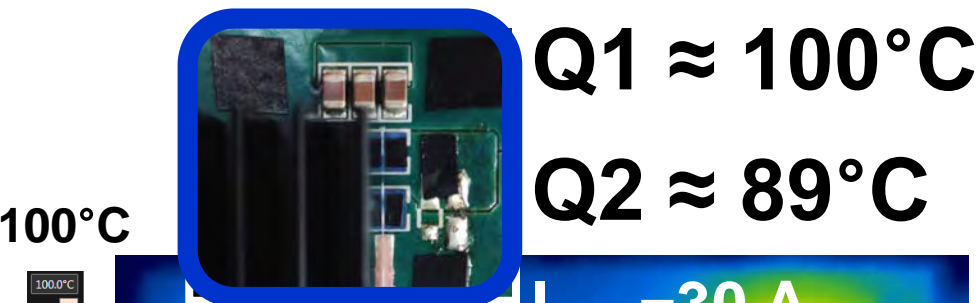
Q1 ≈ 102°C
Q2 ≈ 100°C

100°C



25°C

Fan Speed=400 LFM I_{OUT}=20 A V_{IN}=48 V V_{OUT}=12 V f_{sw}=300 kHz L=4.7 μH



100°C



$I_{OUT}=30\text{ A}$

$I_{OUT}=20\text{ A}$

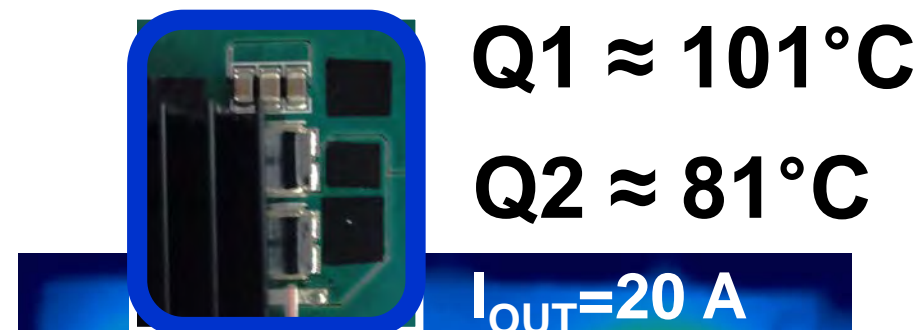


eGaN FET

S308 MOSFET

25°C

Fan Speed=400 LFM $V_{IN}=48\text{ V}$ $V_{OUT}=12\text{ V}$ $f_{sw}=300\text{ kHz}$ $L=4.7\text{ }\mu\text{H}$

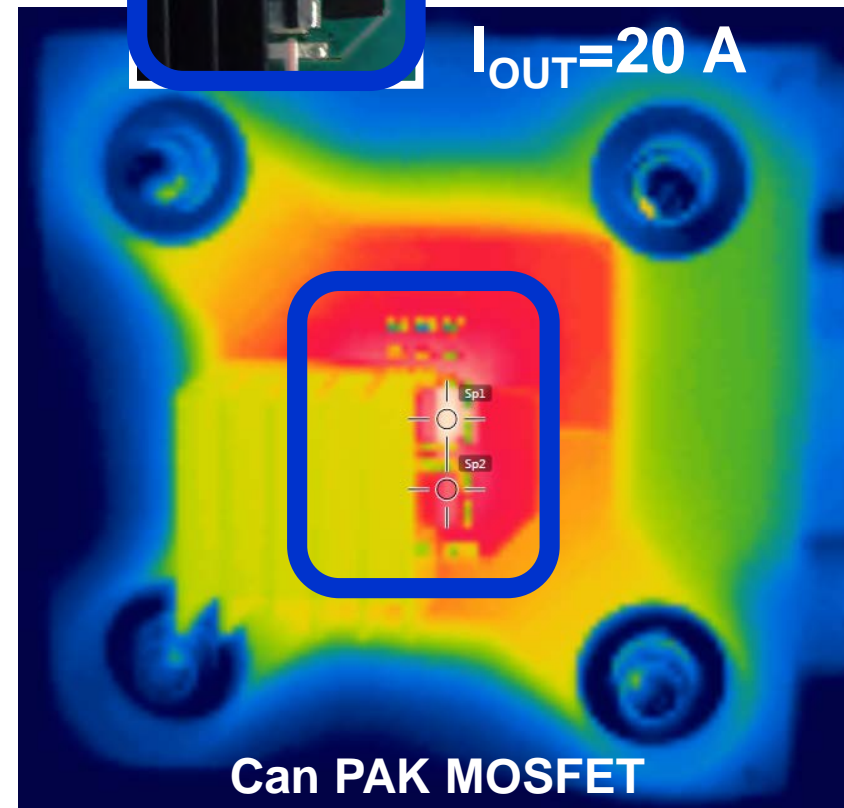
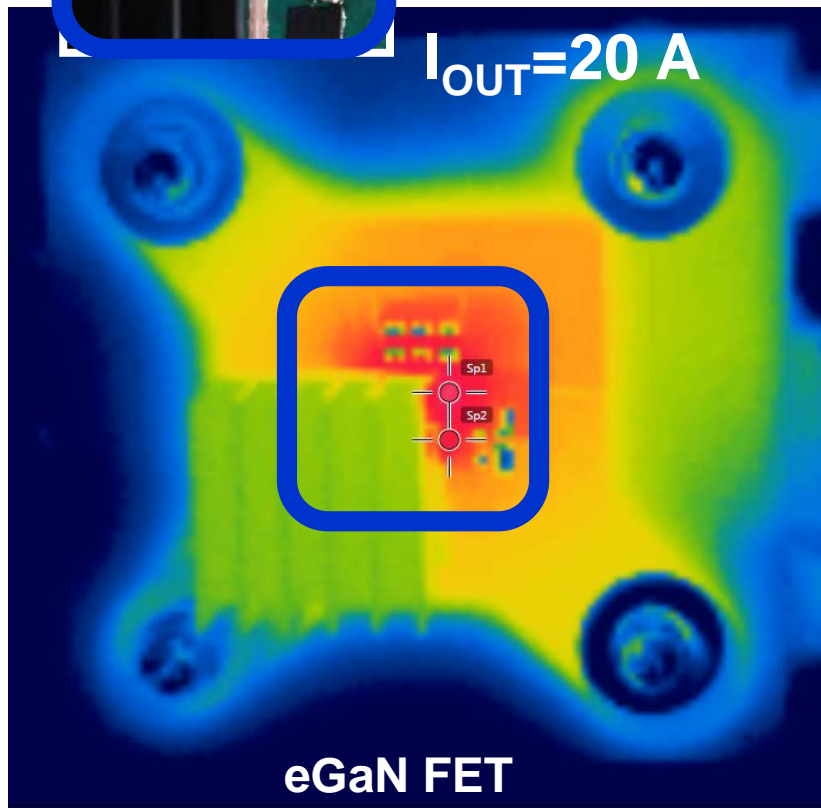


100°C



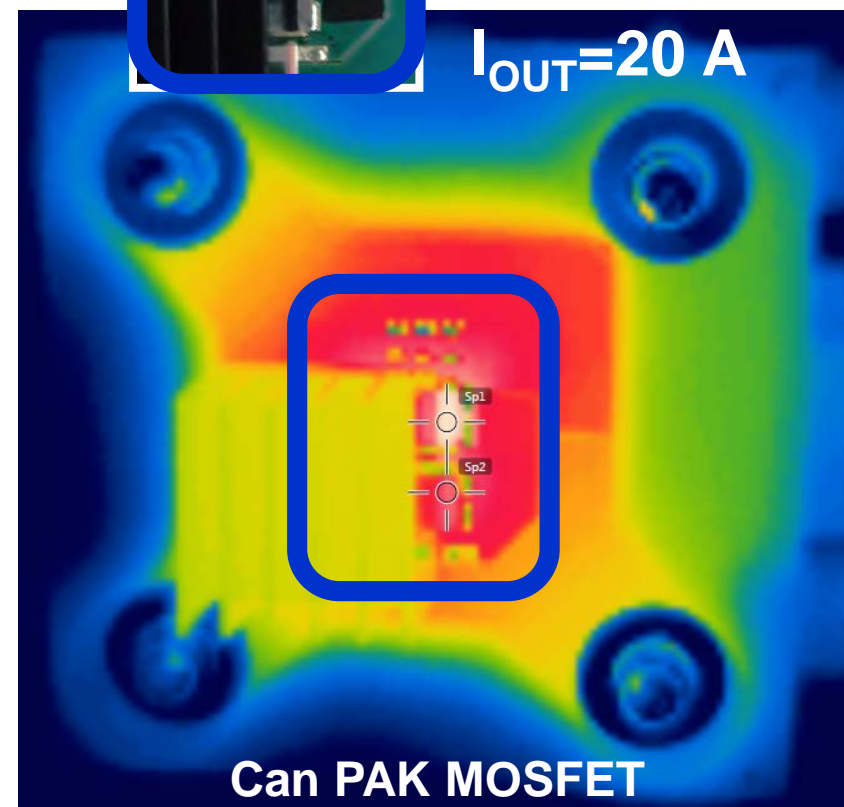
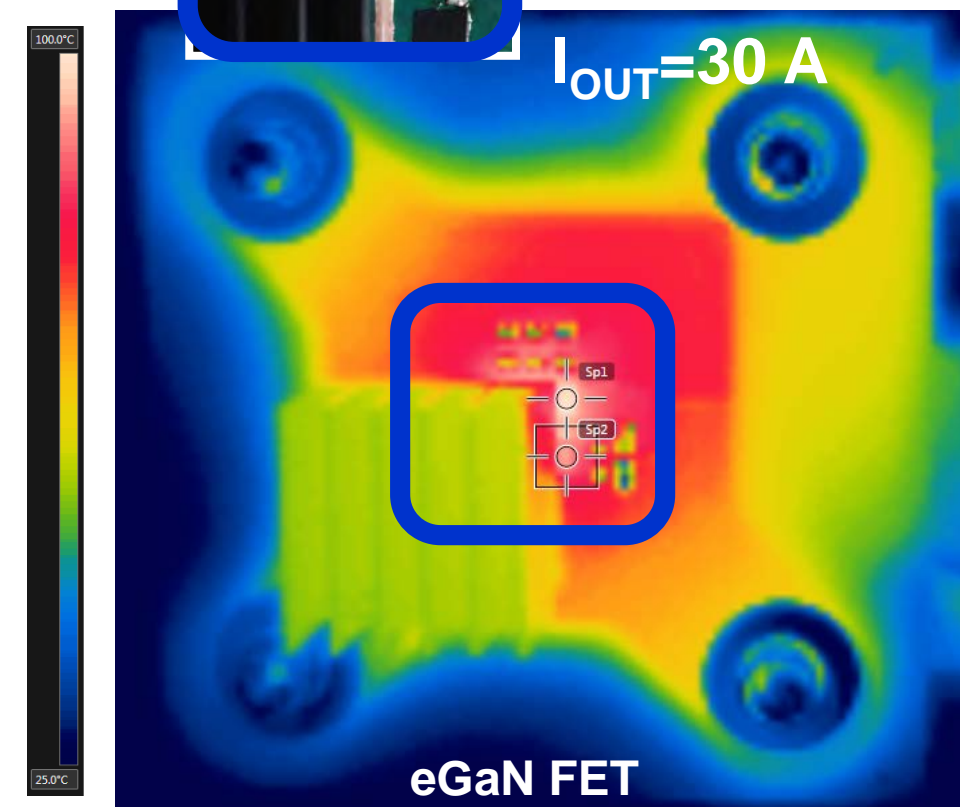
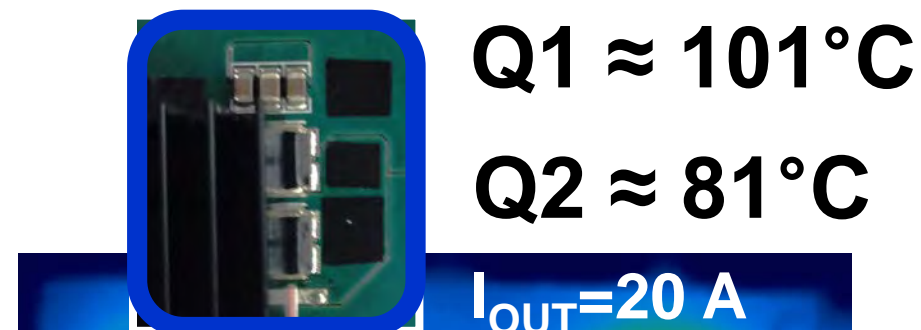
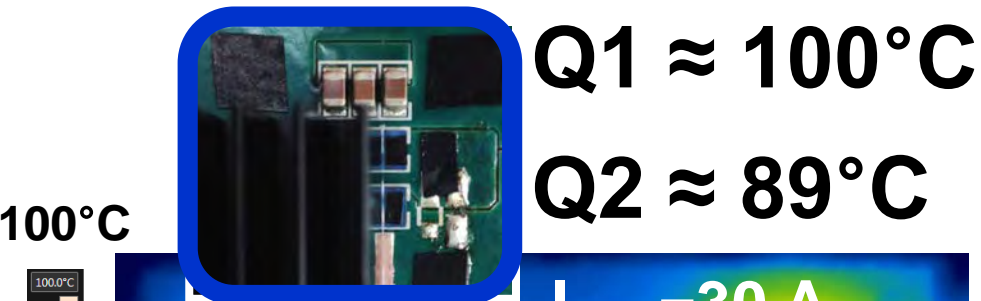
$I_{\text{OUT}}=20\text{ A}$

$I_{\text{OUT}}=20\text{ A}$

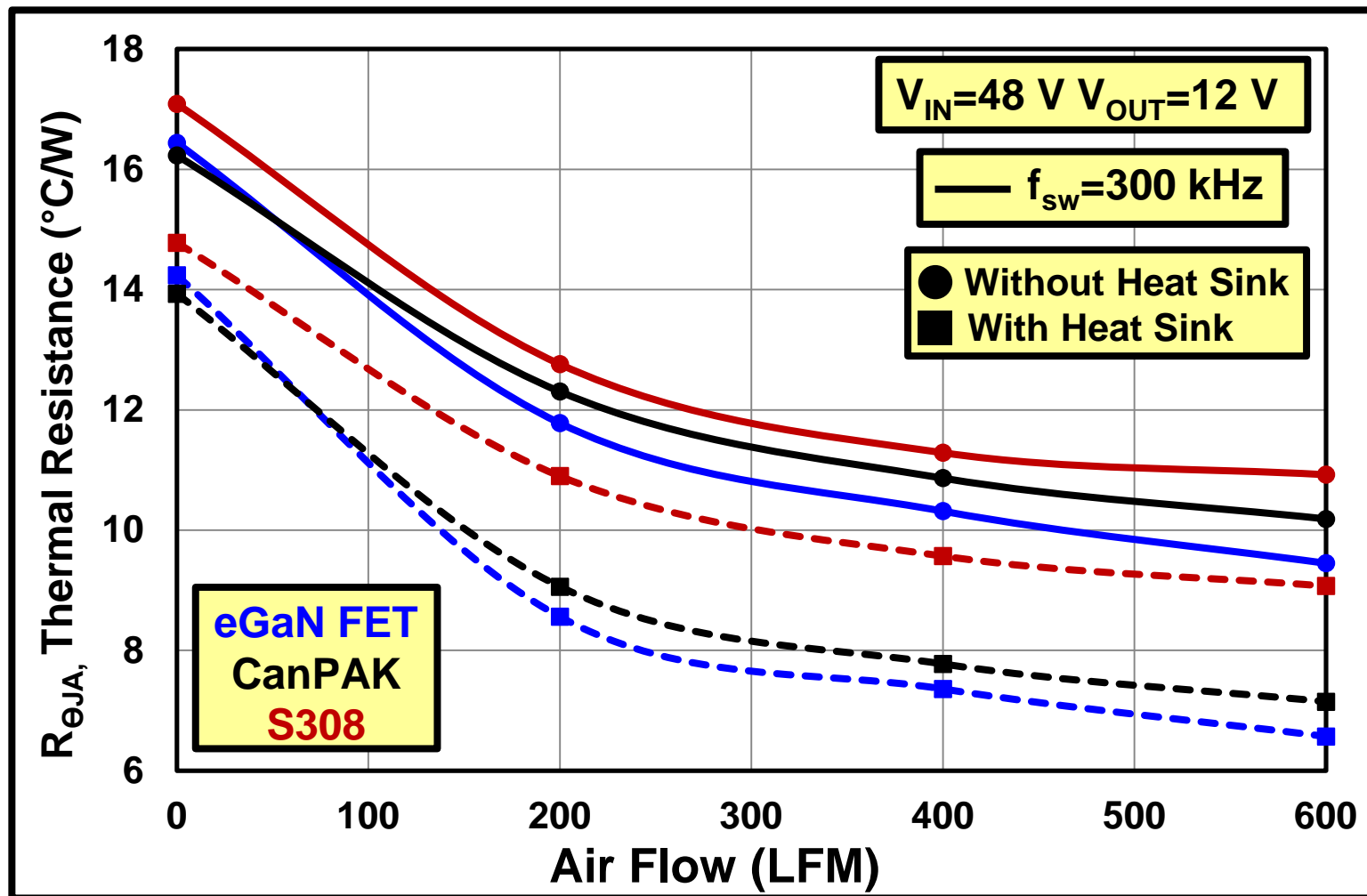


25°C

Fan Speed=400 LFM $I_{\text{OUT}}=20\text{ A}$ $V_{\text{IN}}=48\text{ V}$ $V_{\text{OUT}}=12\text{ V}$ $f_{\text{sw}}=300\text{ kHz}$ $L=4.7\text{ }\mu\text{H}$



Fan Speed=400 LFM $V_{\text{IN}}=48\text{ V}$ $V_{\text{OUT}}=12\text{ V}$ $f_{\text{sw}}=300\text{ kHz}$ $L=4.7\text{ }\mu\text{H}$



Design Examples

48 V_{IN} to Load Voltage

- **Power density**
- **Efficiency**
- **Availability**
- **Cost**
- **Ease of design**
- **Safety**

48 V Isolated Hard-switched Regulated 1/8th Brick Converter

Some typical high-power regulated eighth-bricks

V_{in}	38-55
V_{out}	9.6
I_{out}	31
P_{out}	300
η_{max}	96.1%



V_{in}	42-60
V_{out}	12
I_{out}	25
P_{out}	300
η_{max}	96%

V_{in}	40-60
V_{out}	12
I_{out}	25
P_{out}	300
η_{max}	95.5

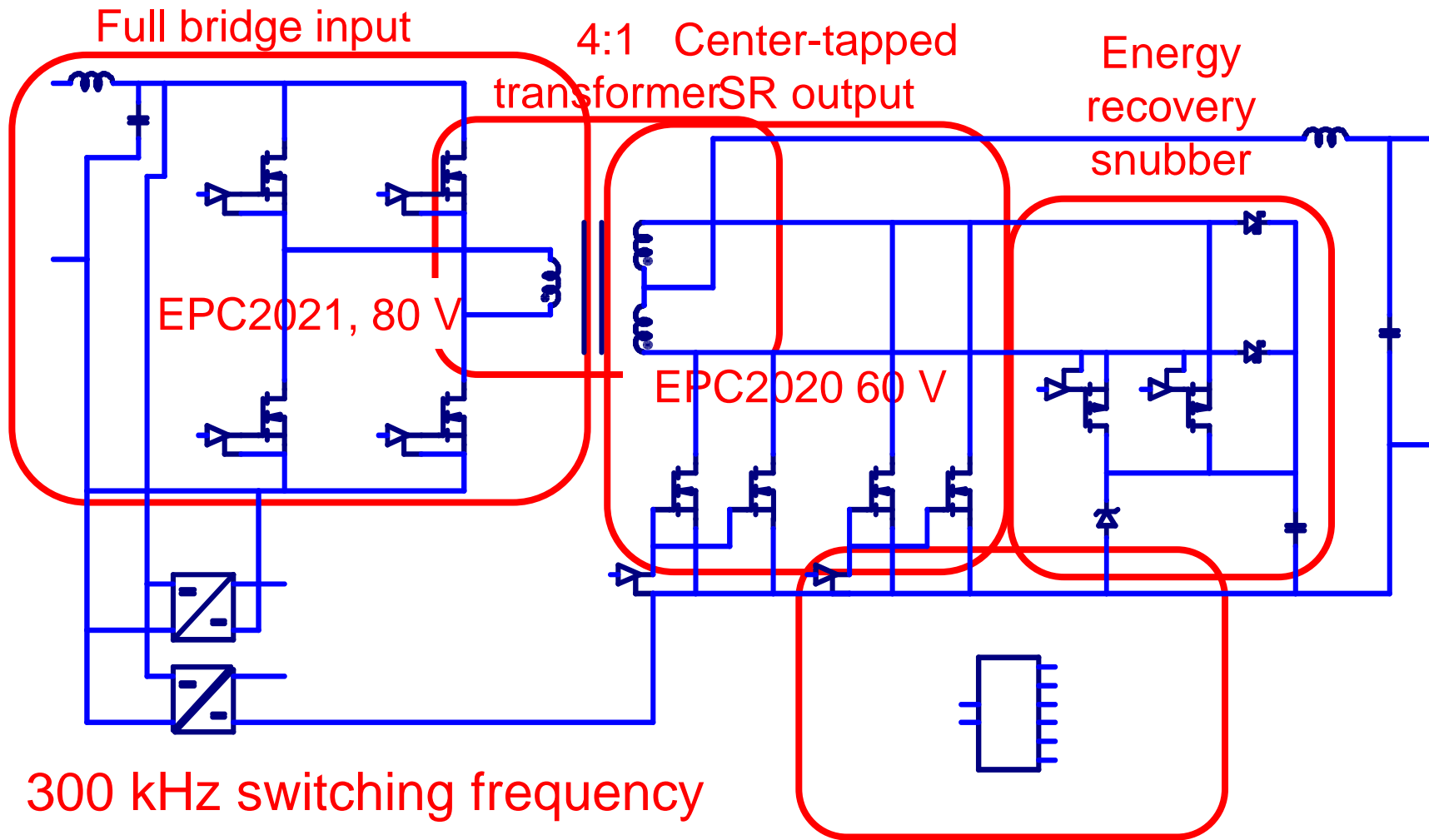


V_{in}	45-55
V_{out}	9.6
I_{out}	33
P_{out}	320
η_{max}	95.5%



eGaN FETs can boost power up to 500W and beyond!

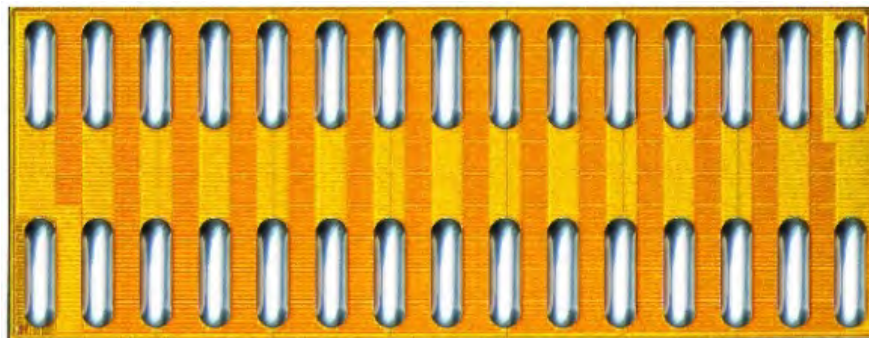
- **500 W at 12 V out**
- **48 V to 60 V in**
- **Fully regulated**
- **Isolated**
- **> 96% full load efficiency**
- **DOSA-compliant footprint**



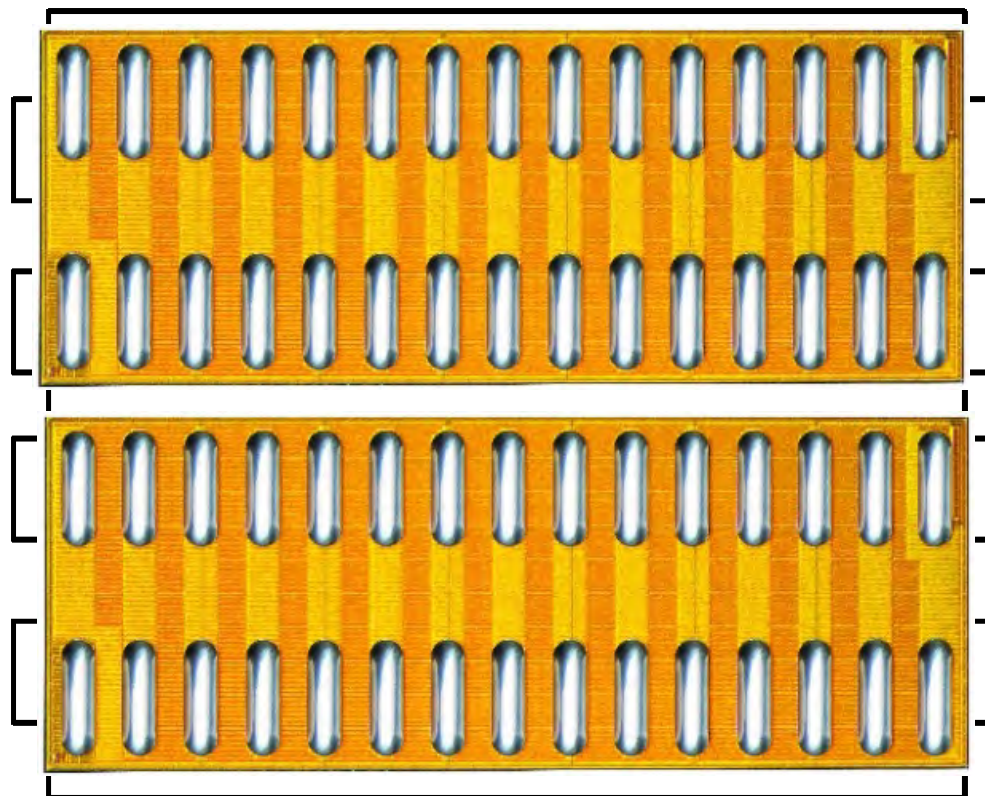
300 kHz switching frequency

Conventional hard-switched PWM

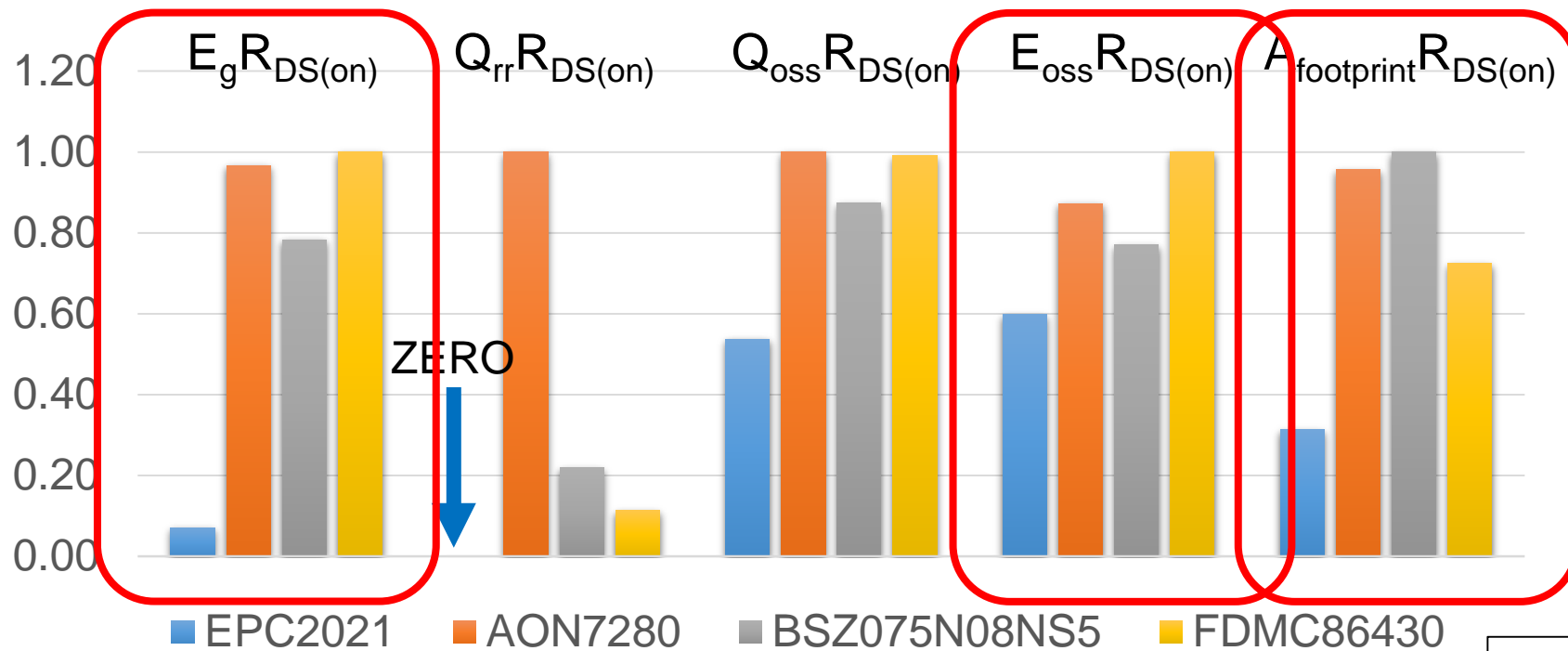
Digital control



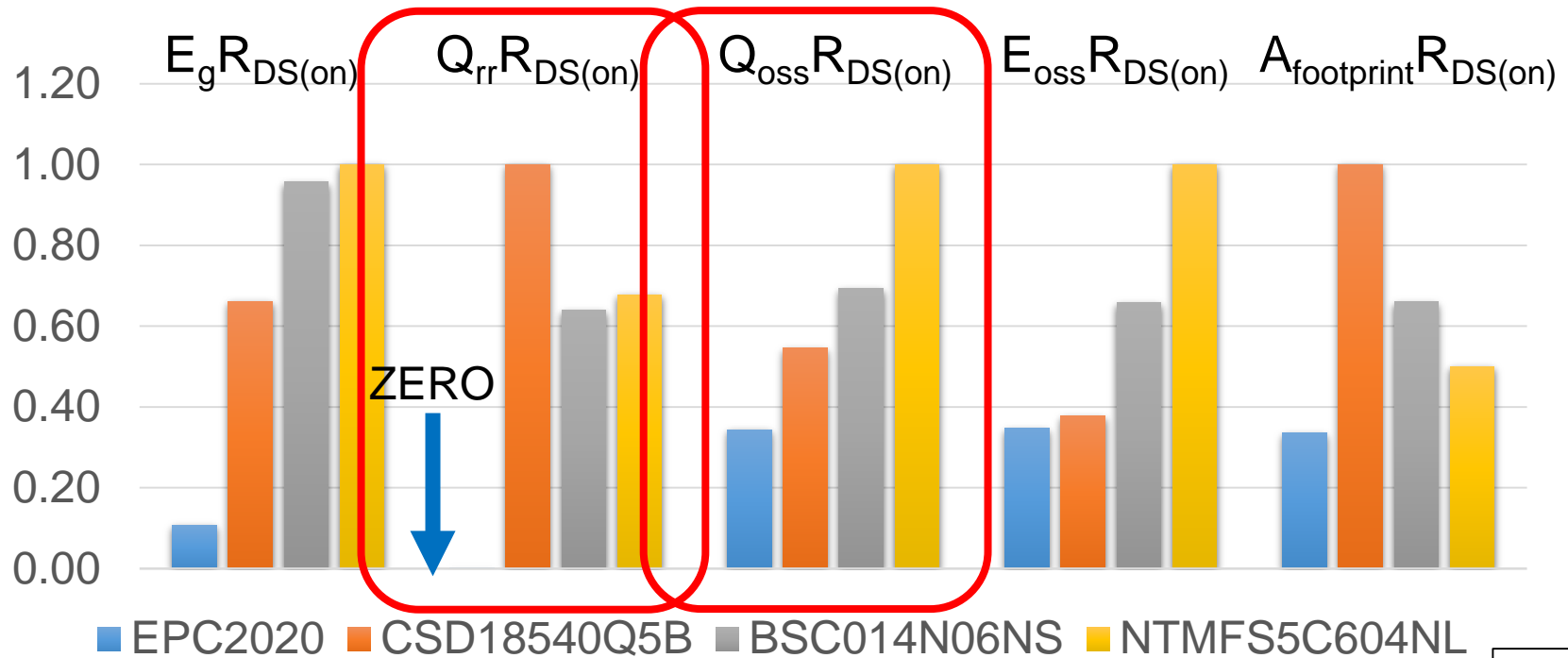
Part	Max V_{DS} [V]	I_D [A]	Max $R_{DS(on)}$ [m Ω]
EPC2020	60 V	60 A	2.0
EPC2021	80 V	60 A	2.5
EPC2022	100 V	60 A	3.2
EPC2023	30 V	60 A	1.3
EPC2024	40 V	60 A	1.5



5X6 PQFN



$V_{DS} = 52 V$



$V_{DS} = 26 V$

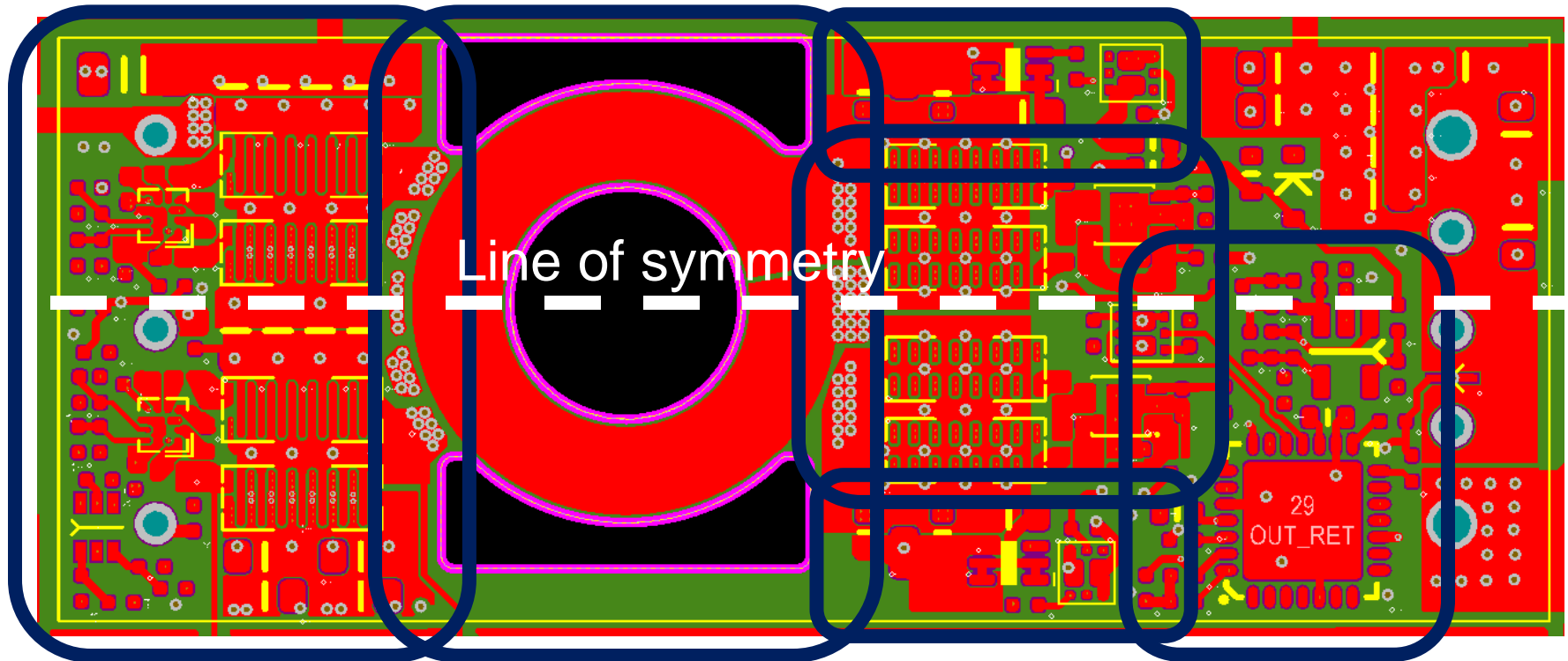
- **Minimize loop inductance**
- **Symmetry for V-s balance**
- **Copper for thermals**
- **Guide power currents away from signal ground**
- **Takes diligence, but doable – the effort pays off!**

Full bridge
input

4:1
transformer

Center-
tapped SR

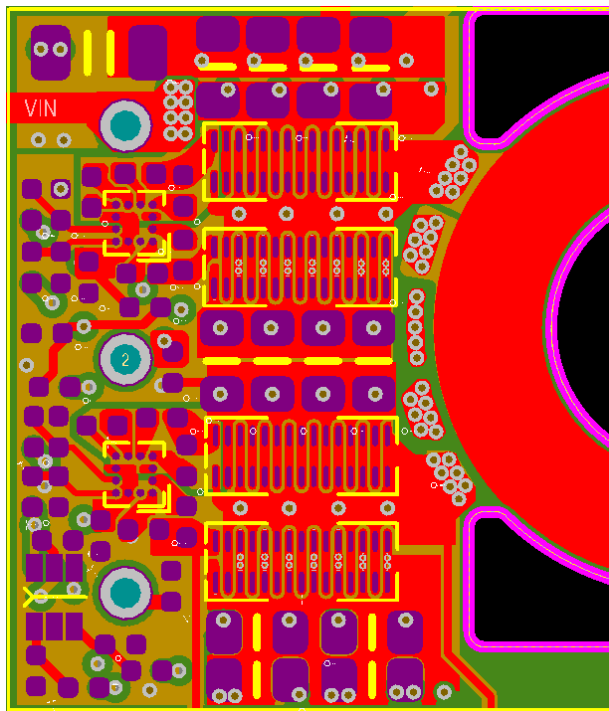
Energy recovery
snubber



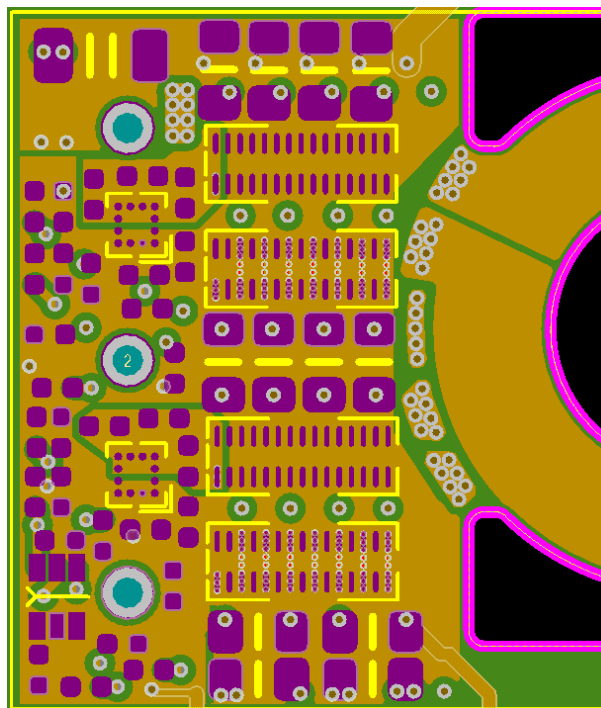
Digital control

Bottom side: input and output filter inductors, bias supply

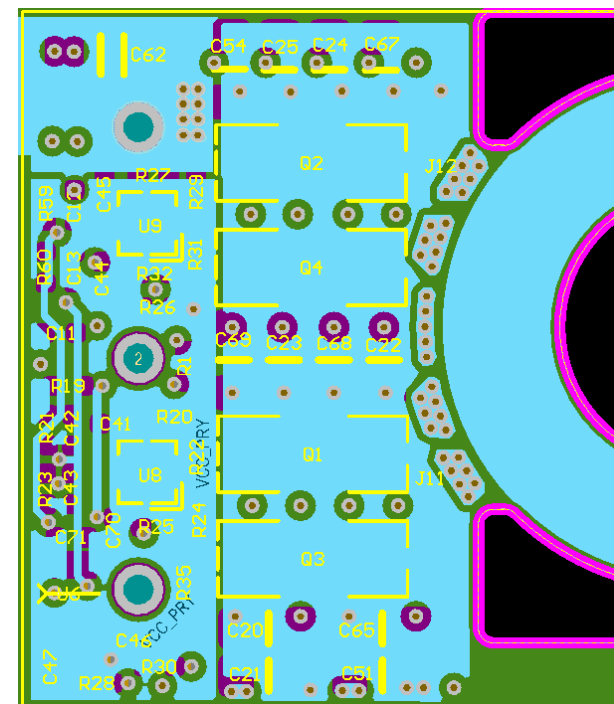
**Top layer:
 V_{IN} , GND, Primary**



**Layer 2:
GND**



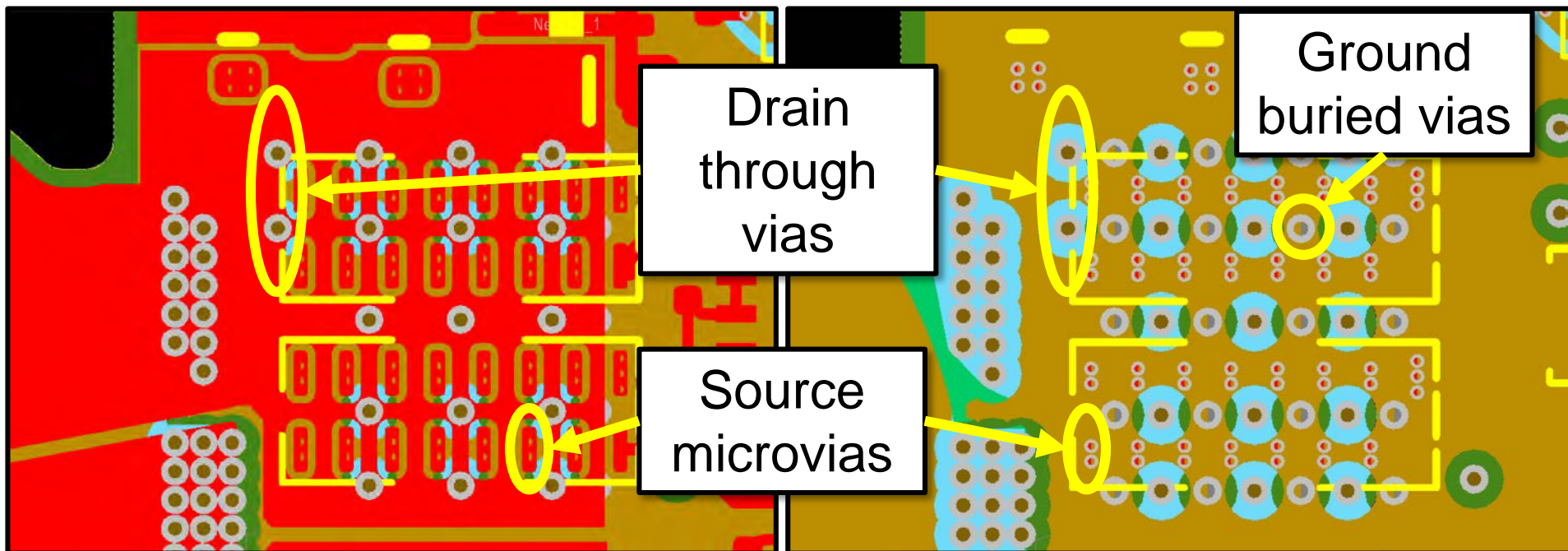
**Layer 3:
 V_{IN}**



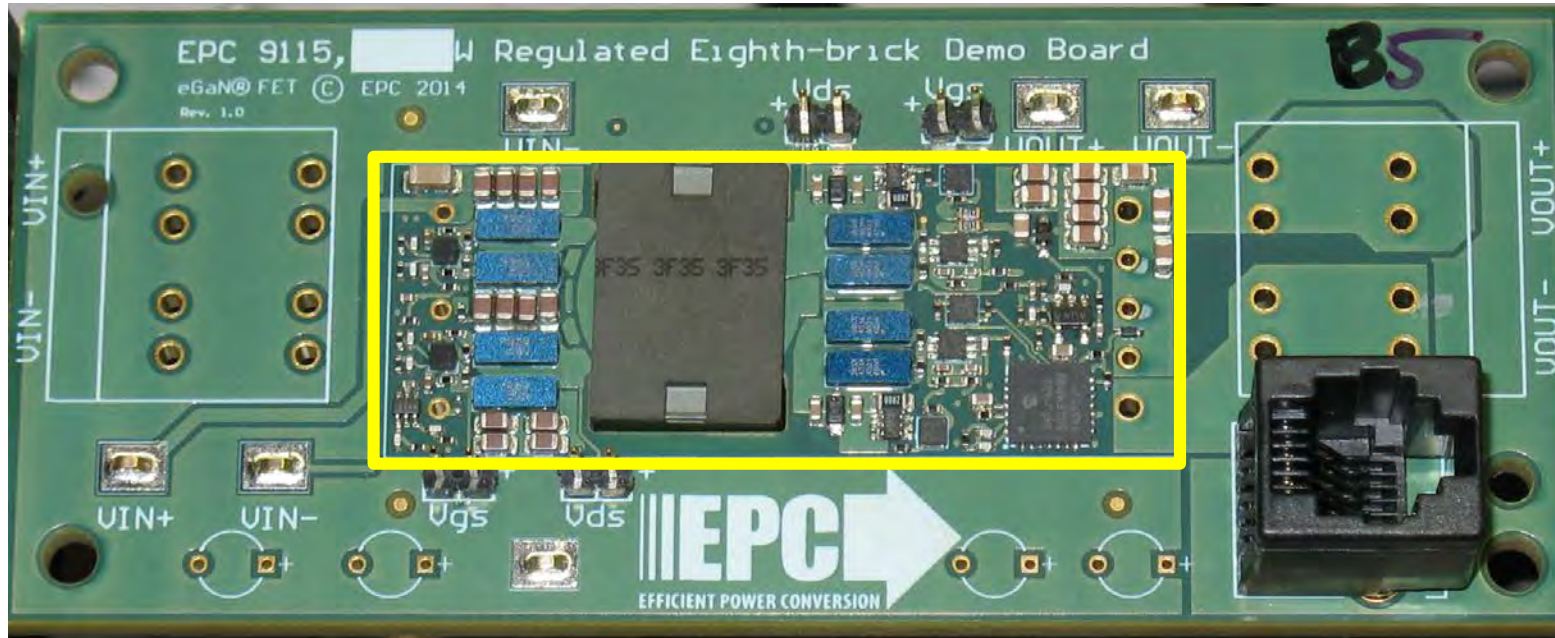
Repeat 4X

Top layer: Drain

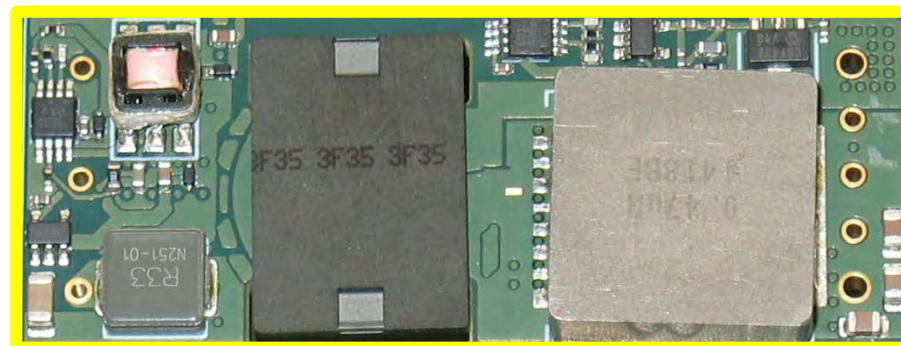
Layer 2: Ground

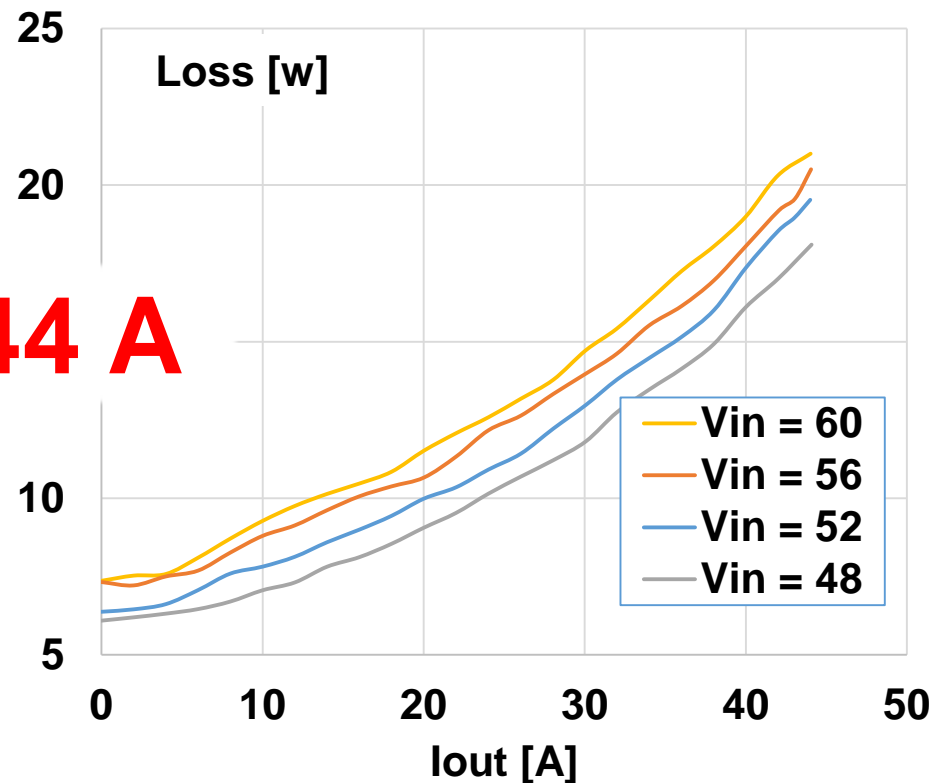
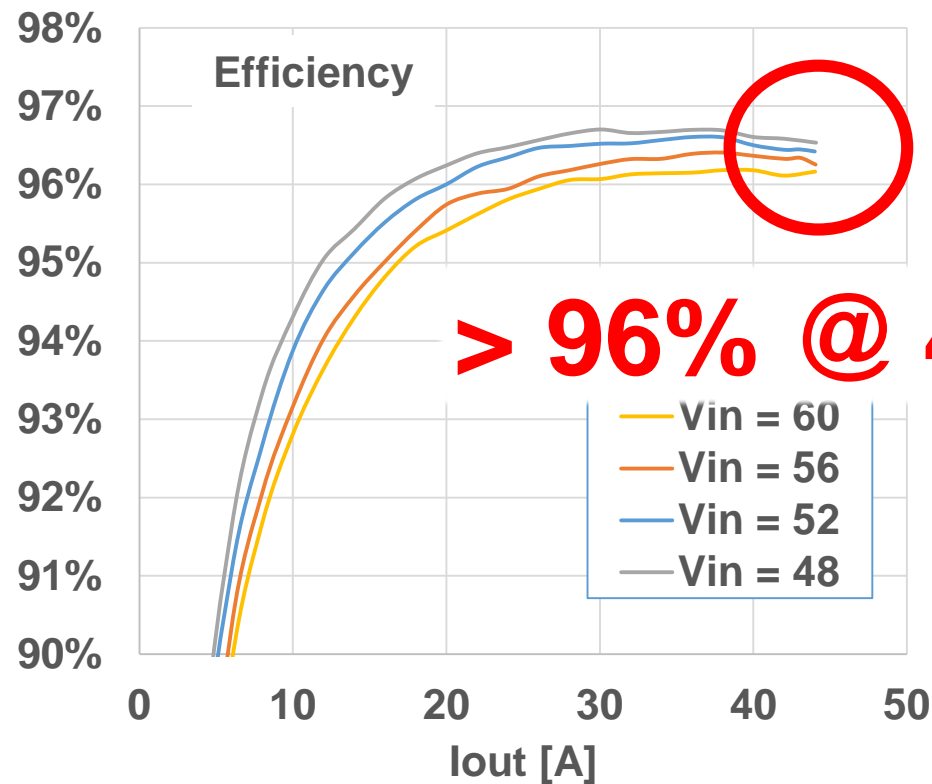


Repeat 4X

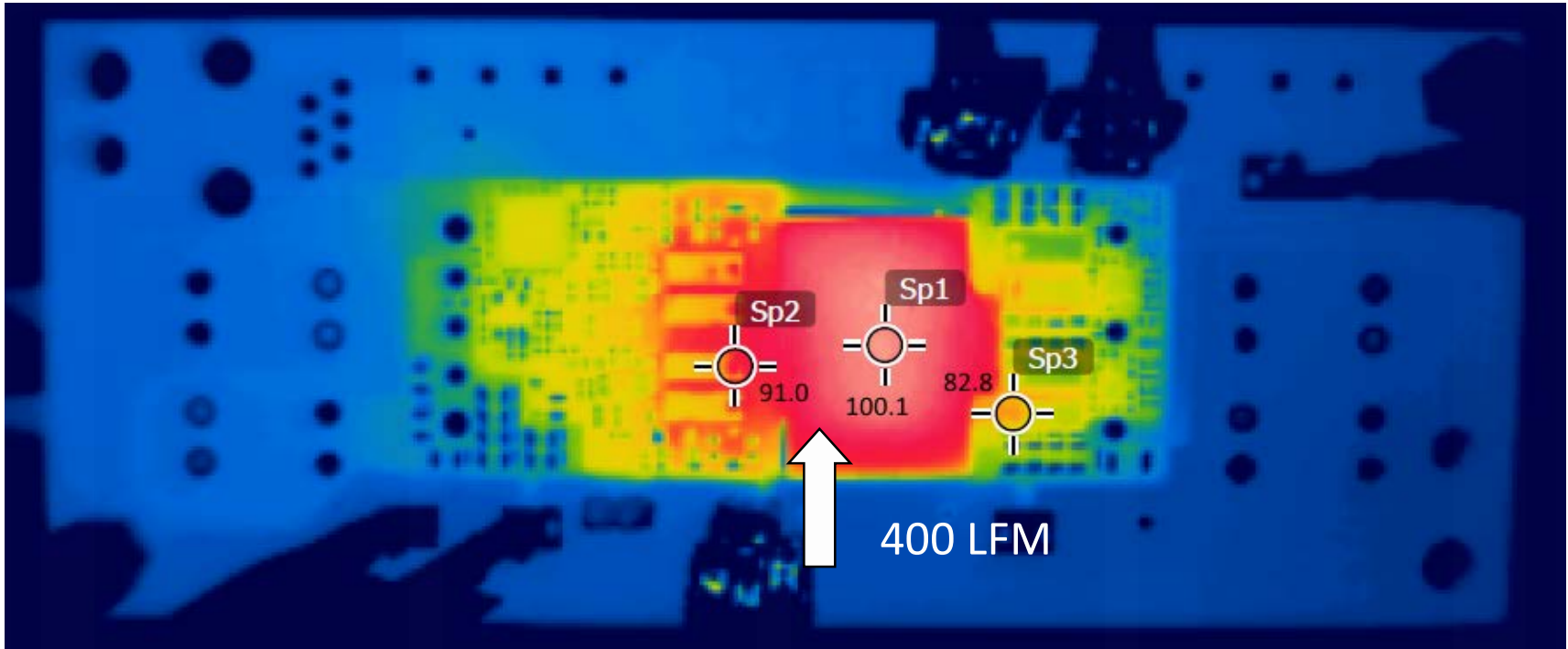


TOP and Bottom views

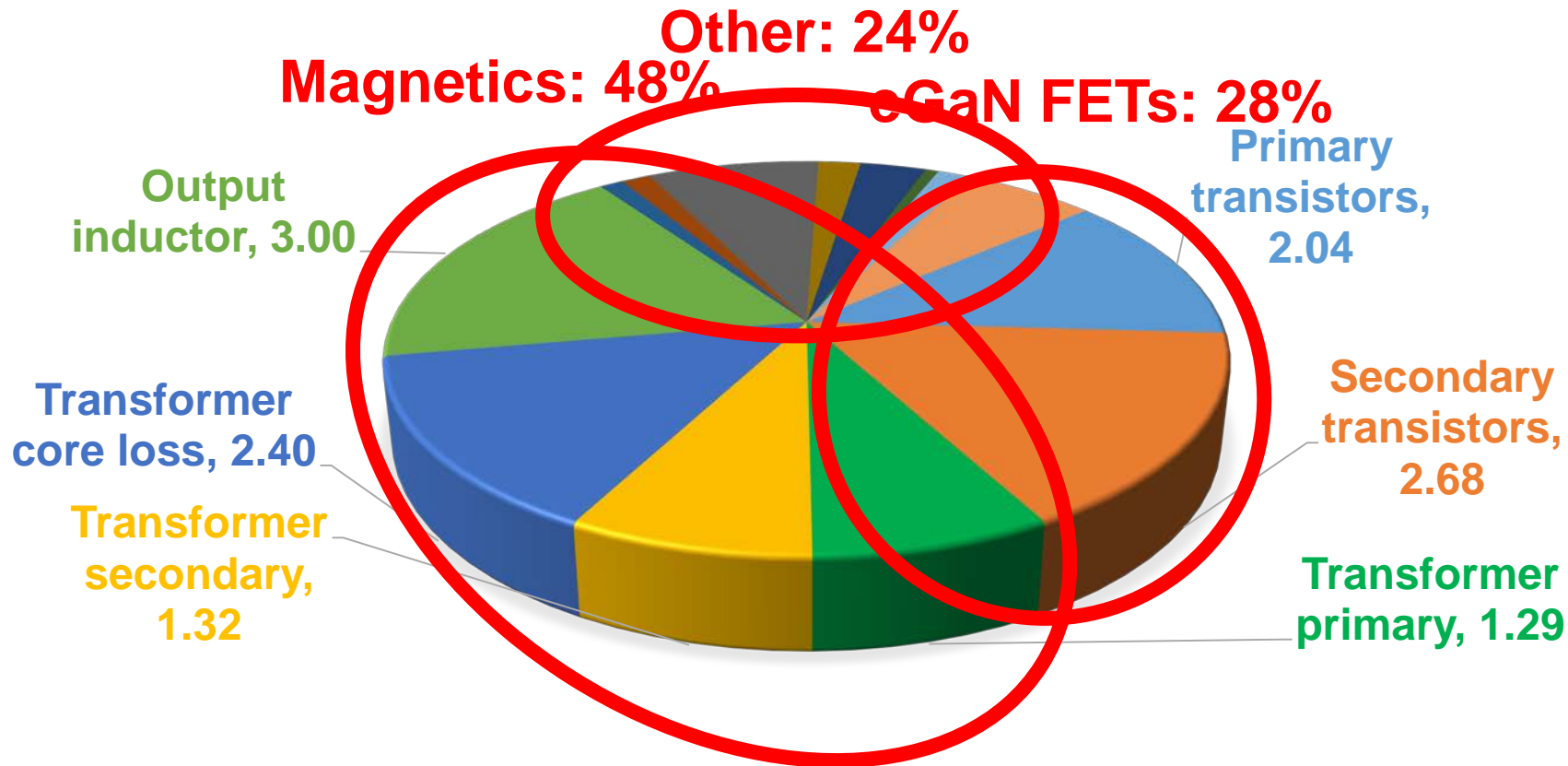




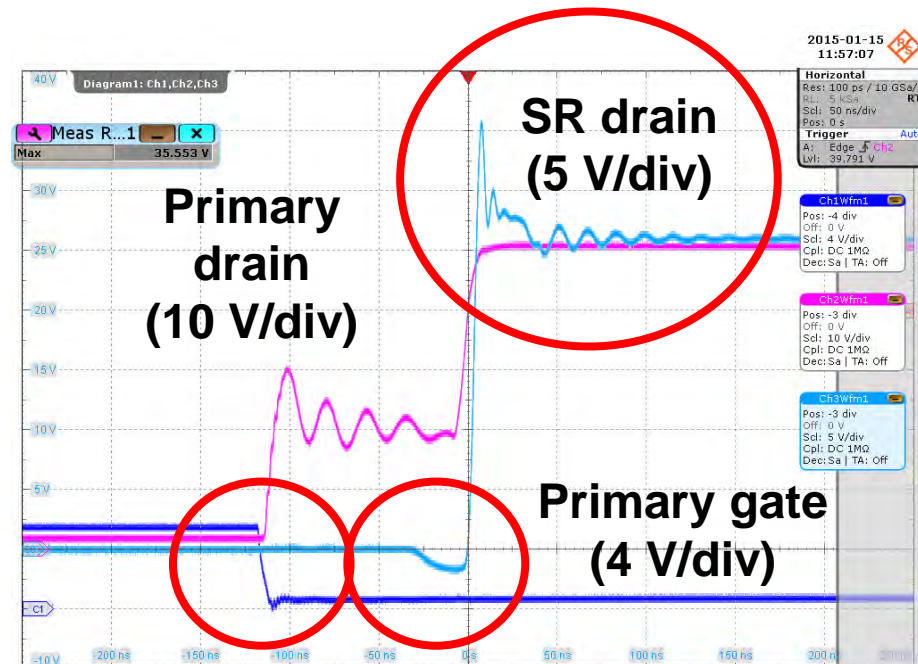
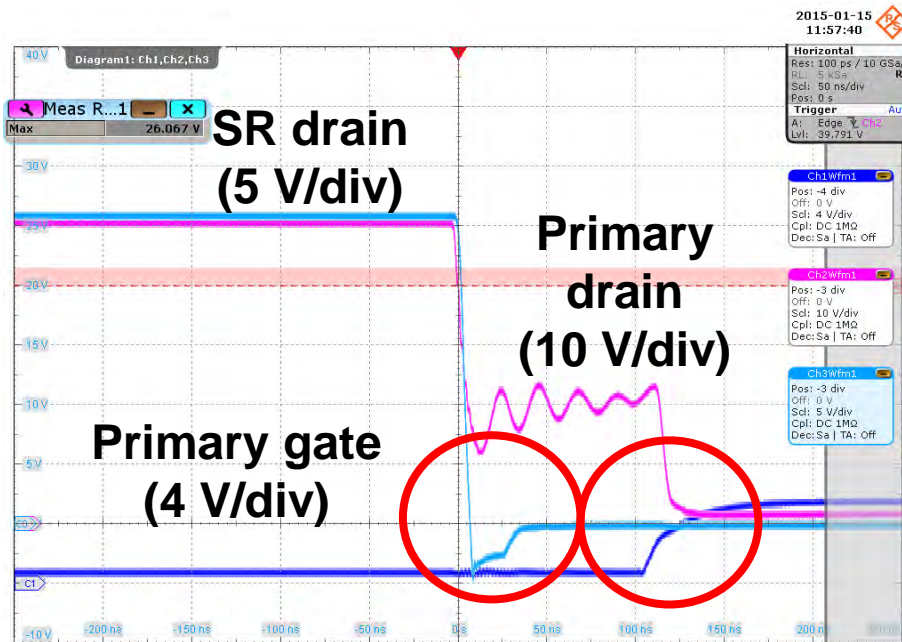
Thermal steady state:
 400 LFM (2 m/s) forced convection
 ambient temperature 27° C



Thermal steady state:
400 LFM (2 m/s) forced convection
ambient temperature 27° C



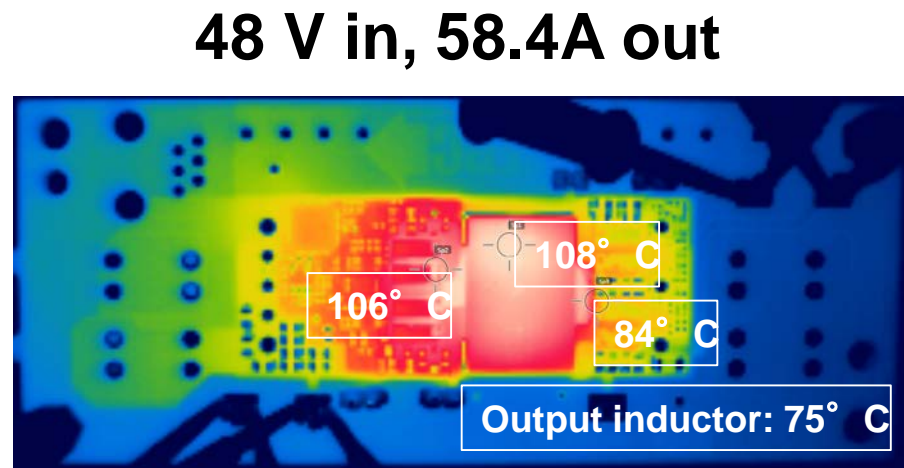
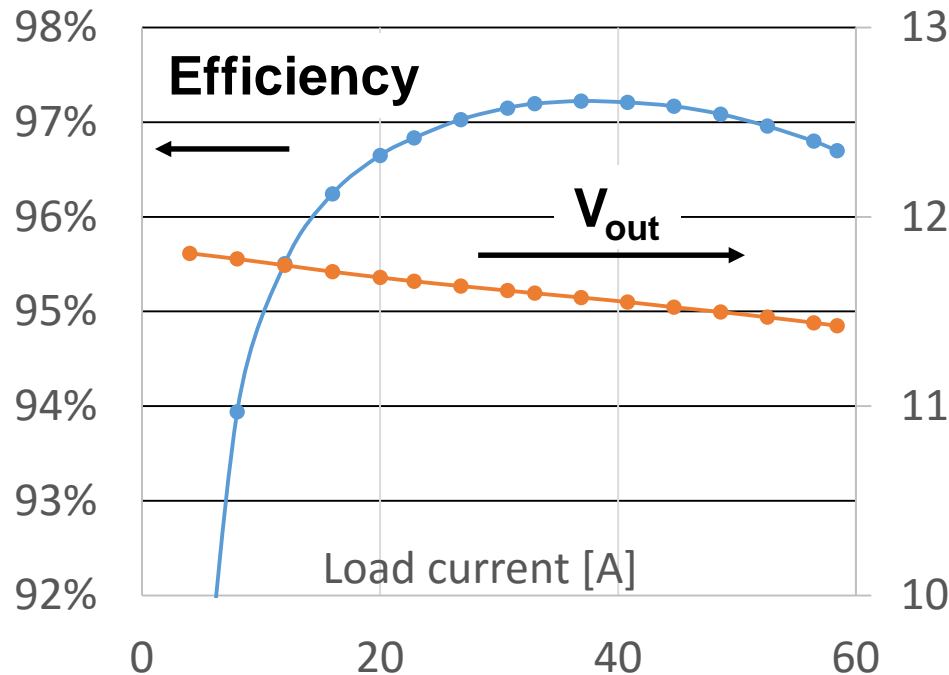
Total: 16.6 W @ 100°C
Excludes: Vias, solder joints, traces



50 ns/div

$$V_{in} = 52 \text{ V}, V_{out} = 12 \text{ V}, I_{out} = 42 \text{ A}$$

- **Improve bias supply (draws 1.3W, but bias load 0.6W)**
- **Add heat sink**
- **Optimize gate resistors**
- **Optimize dead time**
- **Use custom magnetics**
- **Optimize switching frequency**

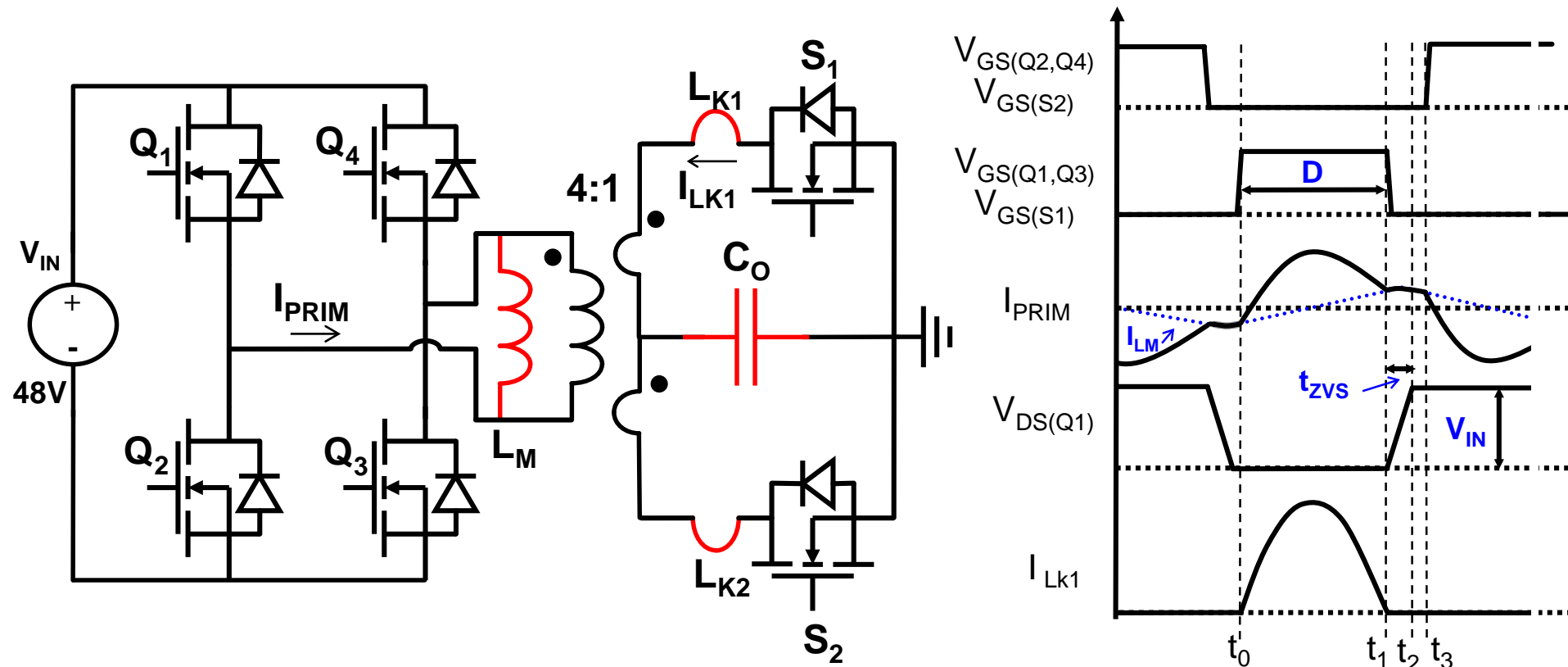


667 W Output

Operating conditions:
400 LFM (2 m/s) forced convection
ambient temperature 24°C
thermal steady state.

Resonant Bus Converter

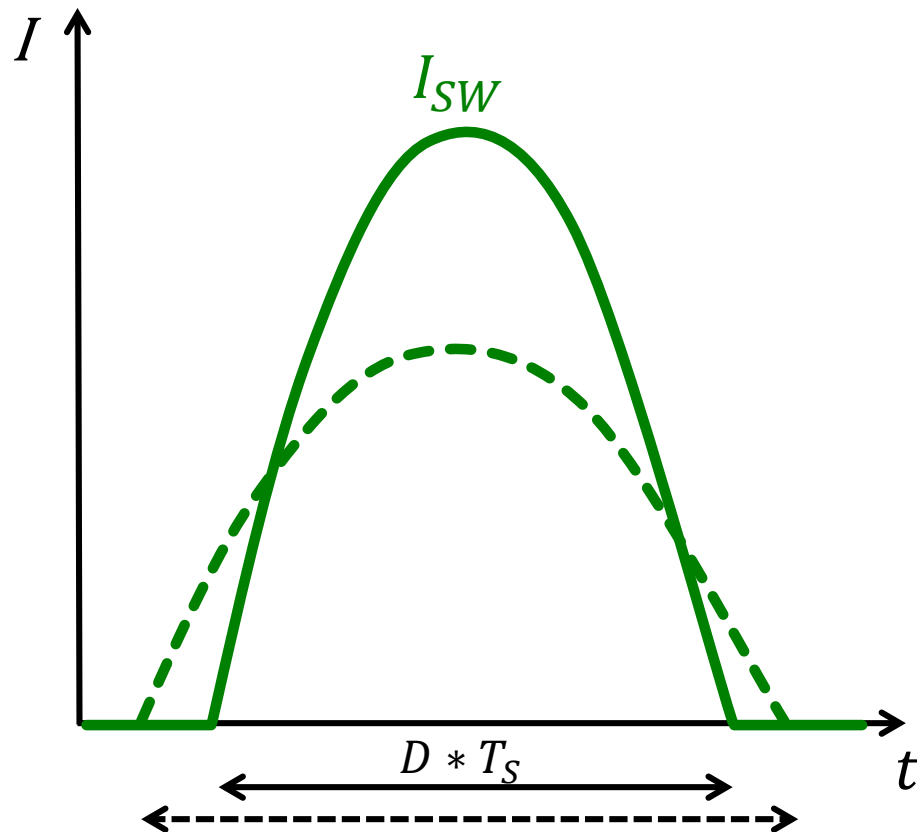
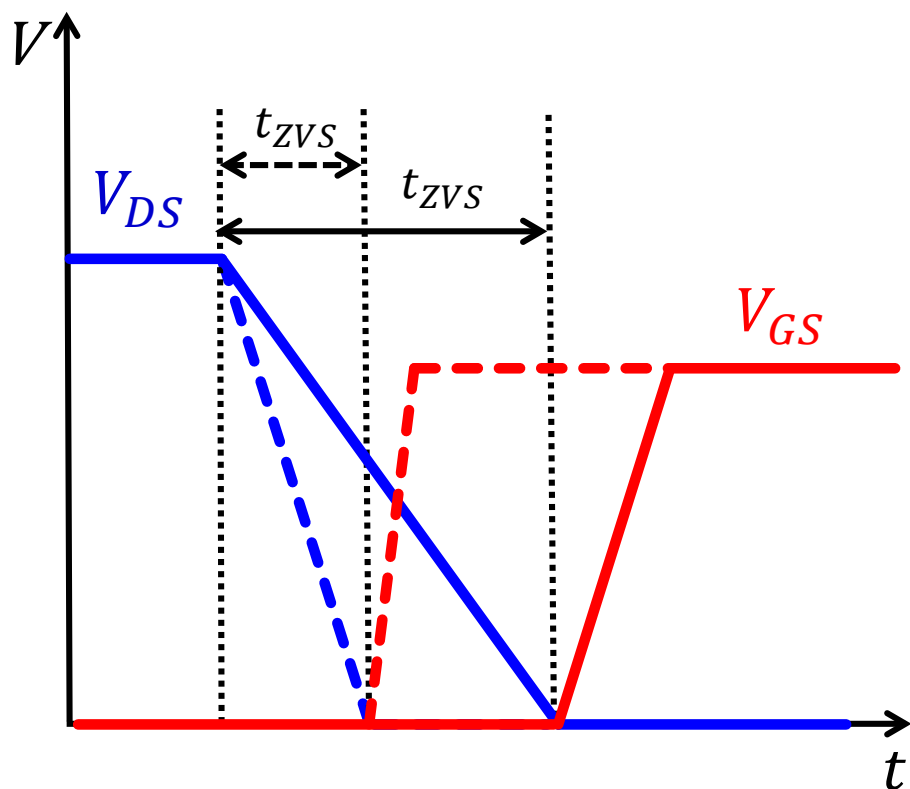
High Frequency DC/DC Transformer

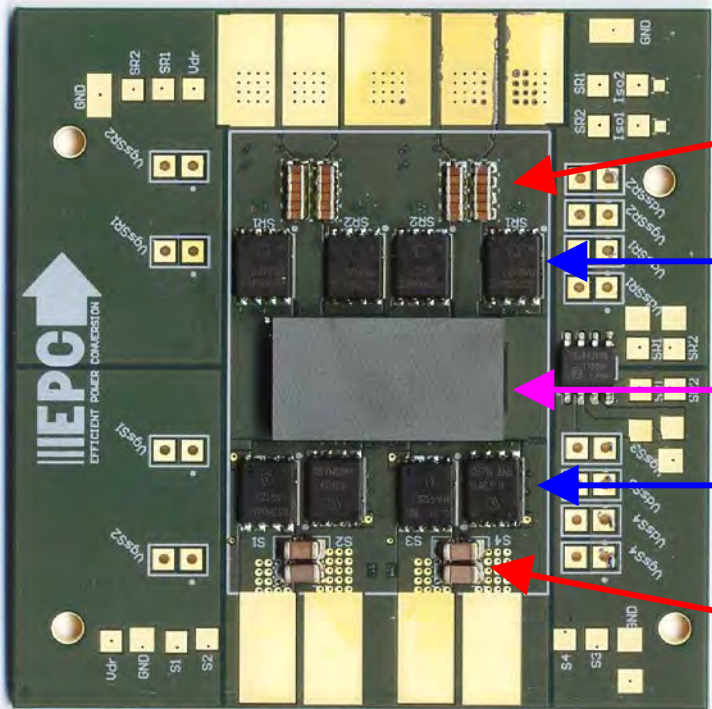


Ref: Y. Ren, M. Xu, J. Sun, and F. C. Lee, "A family of high power density unregulated bus converters," IEEE Trans. Power Electron., vol. 20, no. 5, pp. 1045–1054, Sep. 2005.

$Q_{oss} \downarrow$ $t_{zvs} \downarrow$

$I_{RMS} \downarrow$ $P_{CON} \downarrow$





MOSFET

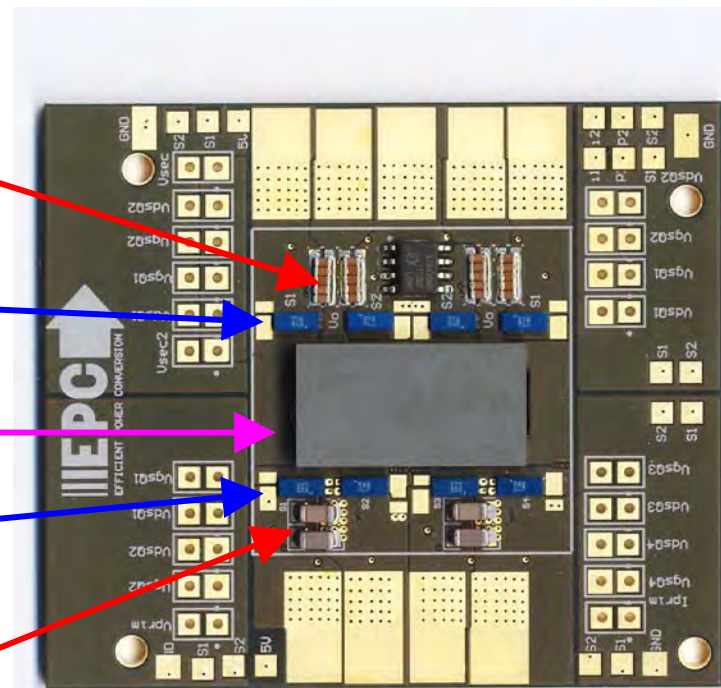
Resonant Capacitors

Secondary Devices

Transformer

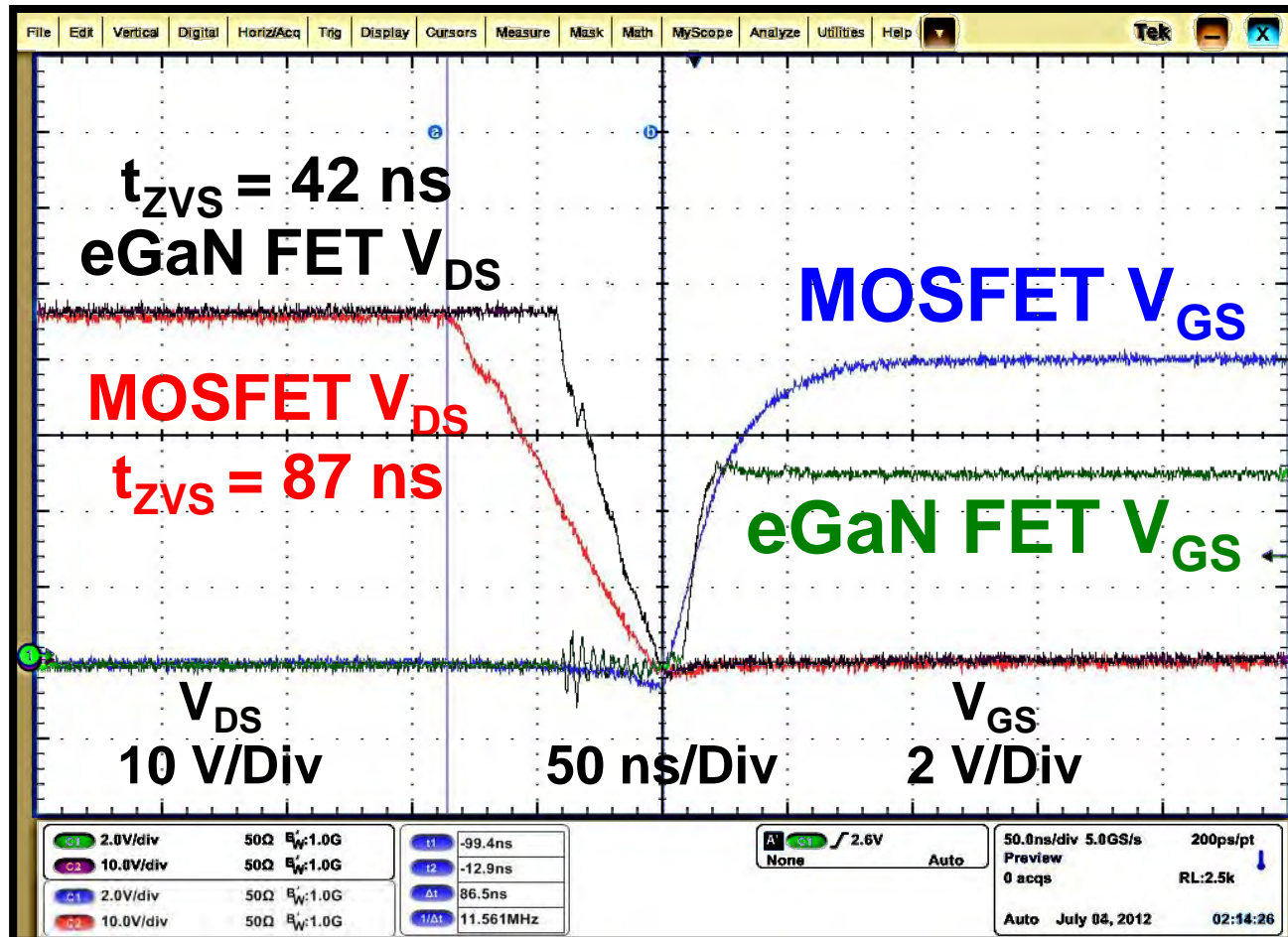
Primary Devices

Input Capacitors



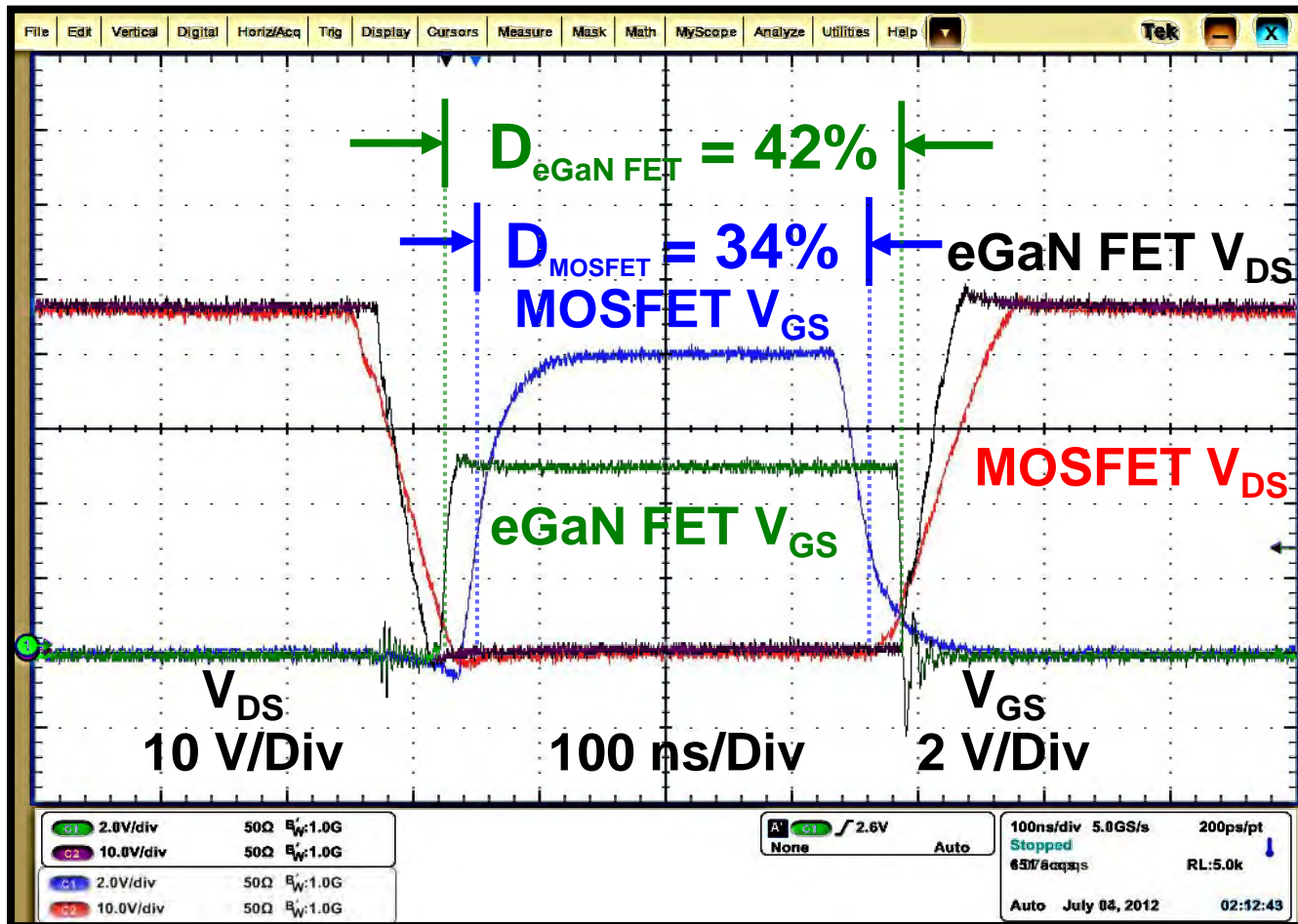
eGaN[®]FET

vs.

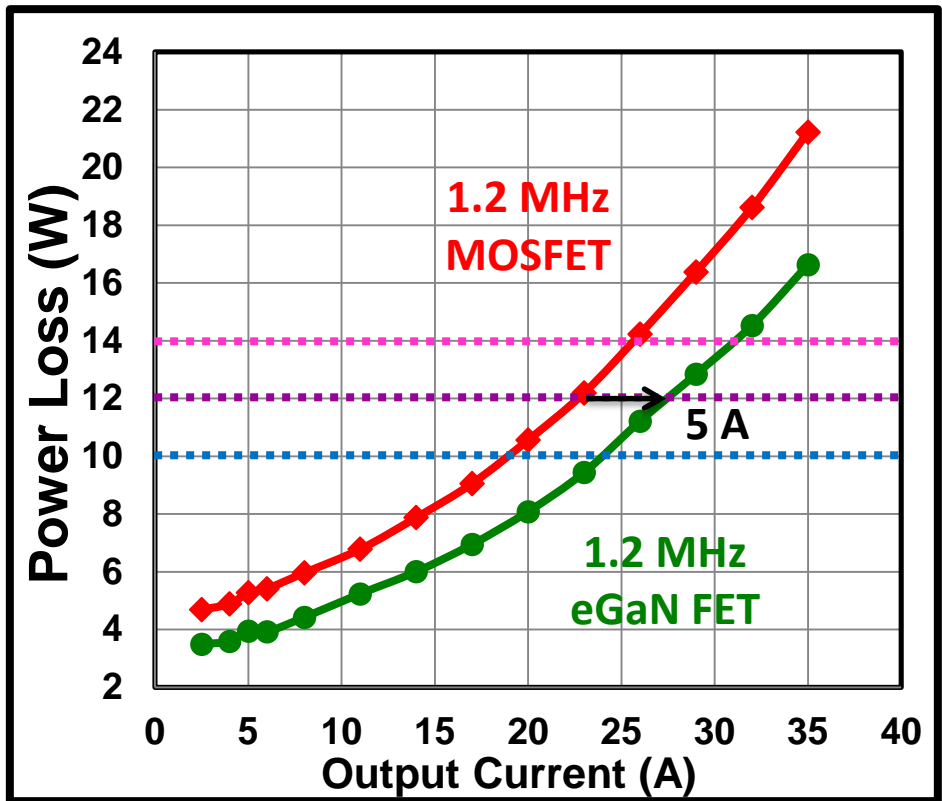
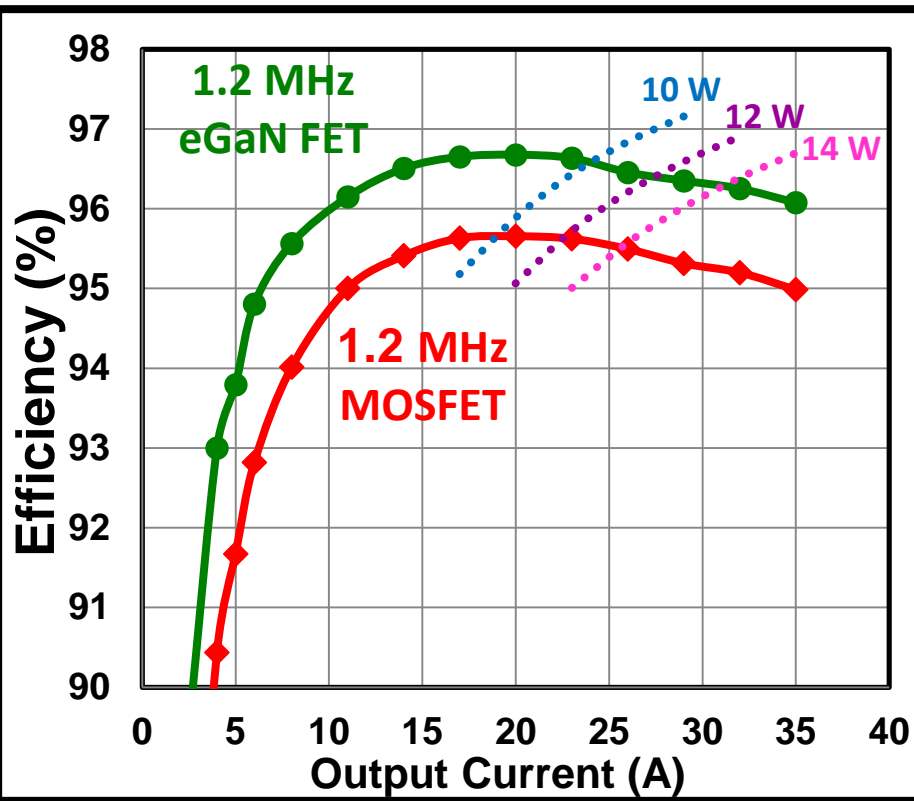


$f_{sw} = 1.2 \text{ MHz}$, $V_{IN} = 48 \text{ V}$, and $V_{OUT} \approx 12 \text{ V}$

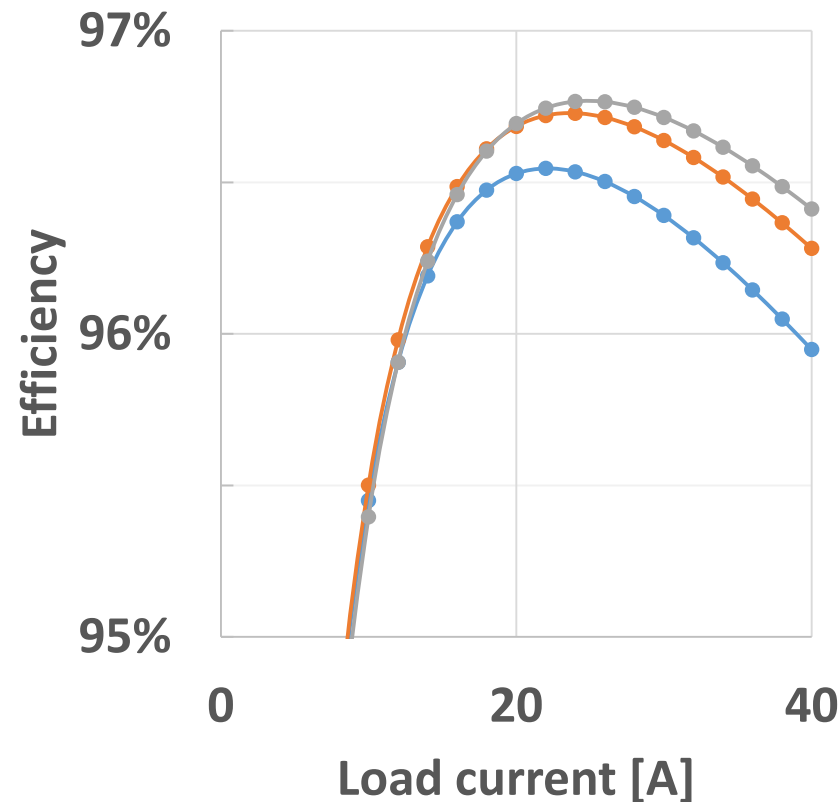
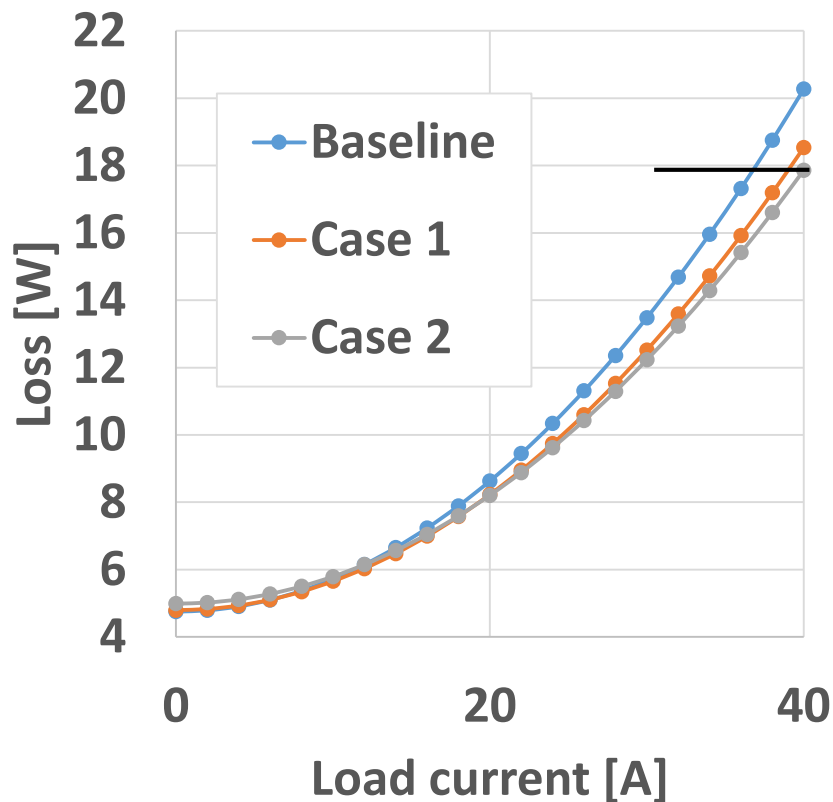
Ref: D. Reusch, J. Strydom, "Evaluation of Gallium Nitride Transistors in High Frequency Resonant and Soft-Switching DC-DC Converters," APEC 2014, IEEE Transactions on Power Electronics 2015



$$f_{sw} = 1.2\text{ MHz}, V_{IN} = 48\text{ V}, \text{ and } V_{OUT} \approx 12\text{ V}$$

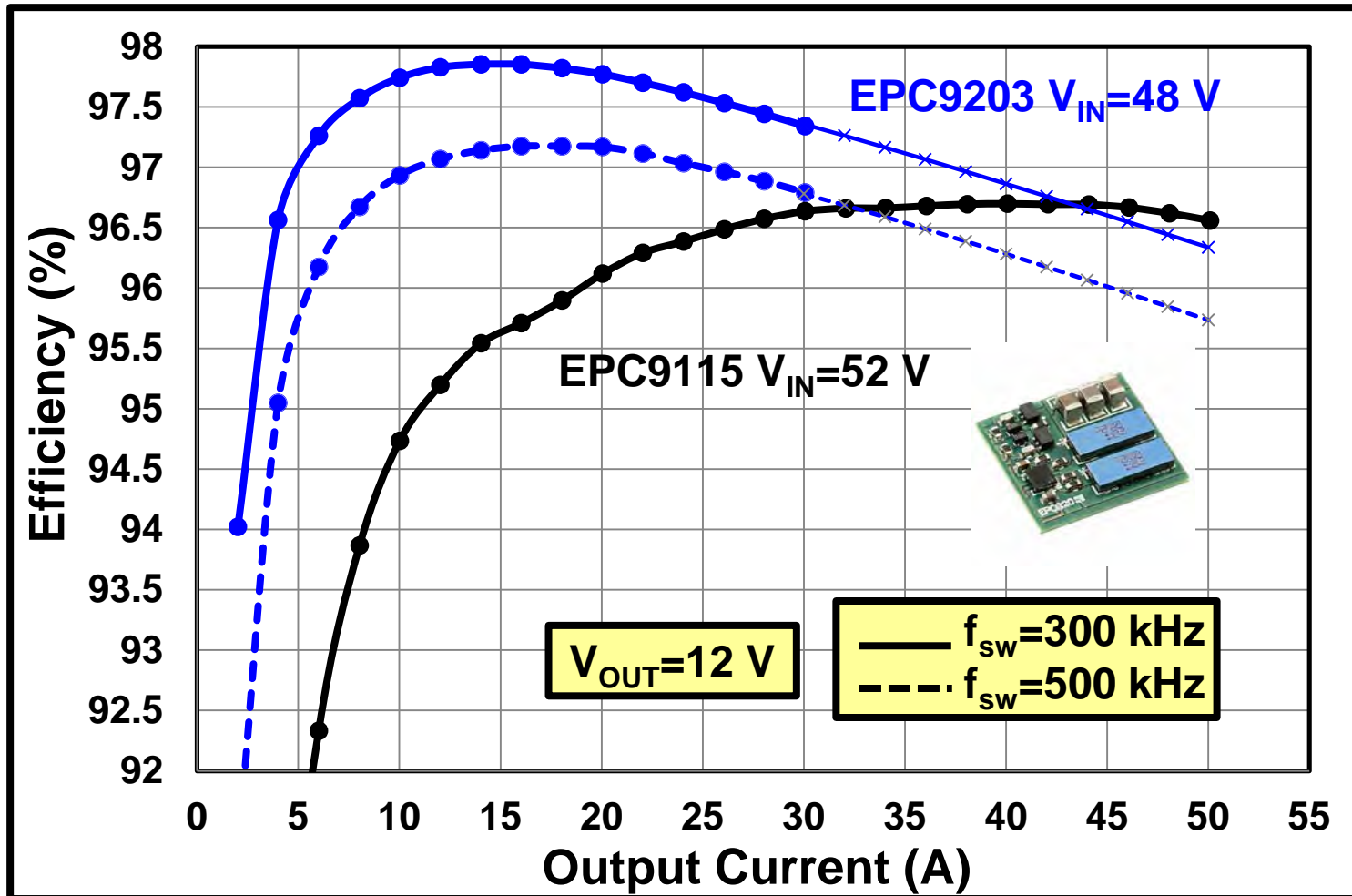


$f_{sw} = 1.2 \text{ MHz}, V_{IN} = 48 \text{ V}, \text{ and } V_{OUT} \approx 12 \text{ V}$



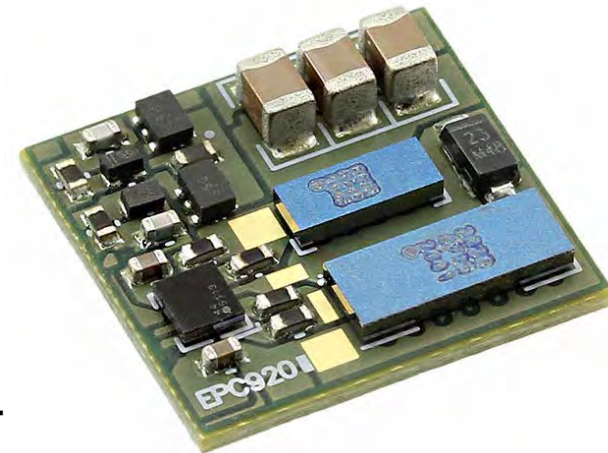
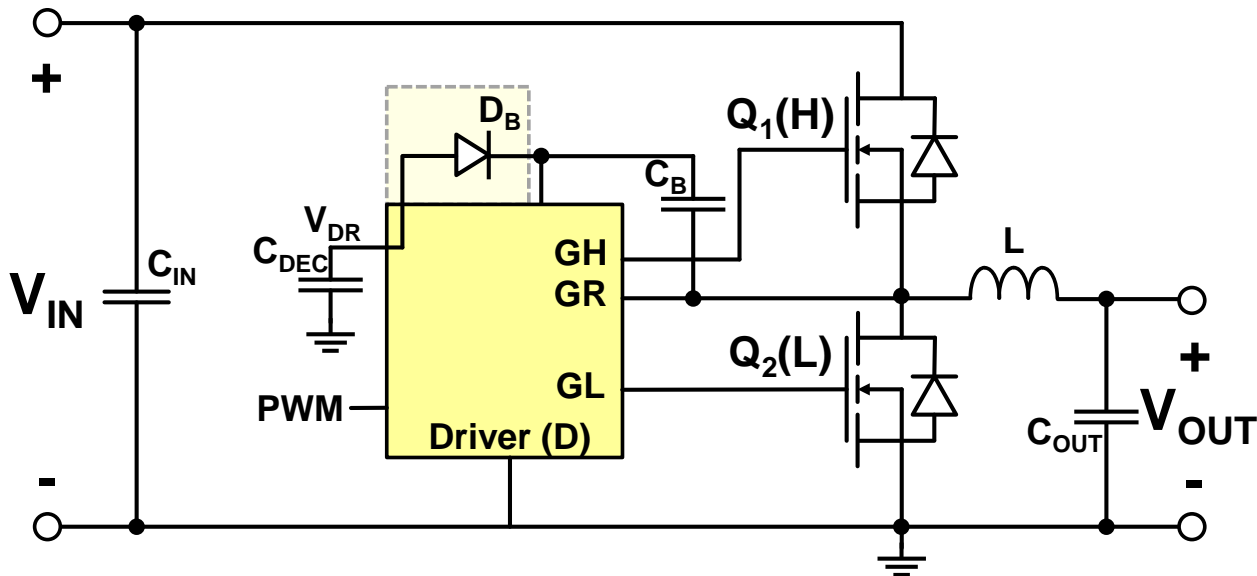
$$P_{loss} = R_{out} I_{OUT}^2 + P_{fixed}$$

Non-isolated bus converter

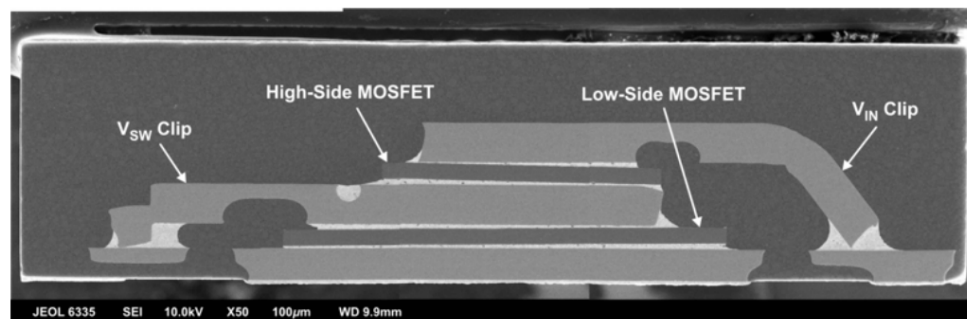
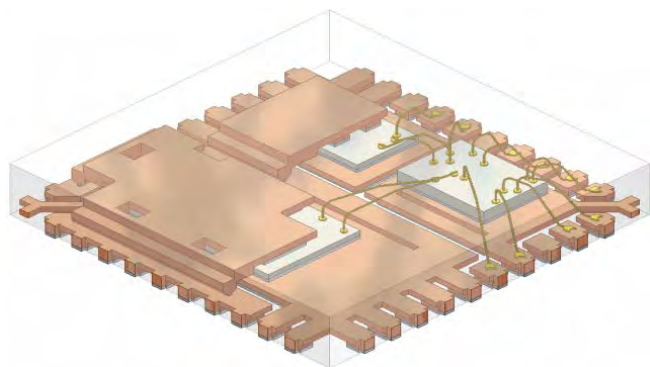


	Units	1/8 th -brick	Buck
Converter volume	in³ (cm³)	0.92 (15)	0.73 (12)
Input voltage	V	49-60	13-65
Output current	A	42	42
Power density	W/in³ (W/cm³)	550 (34)	690 (42)
# FETs		8	2
# Gate drivers		4	1
# PCB layers		12	4

12 V_{IN} to 1 V_{OUT} POL Converter

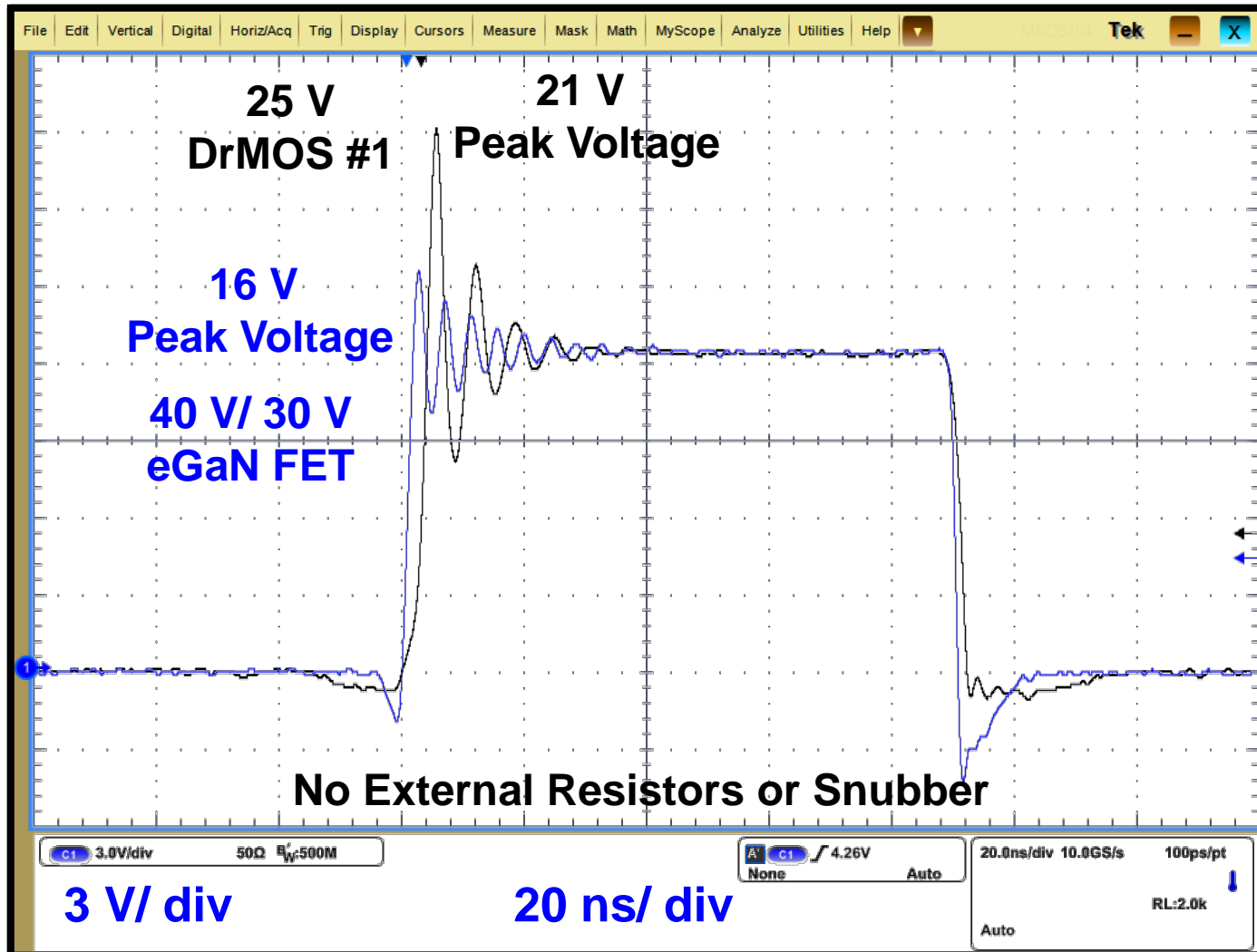


<http://media.digikey.com/photos/EPC/EPC9201.JPG>

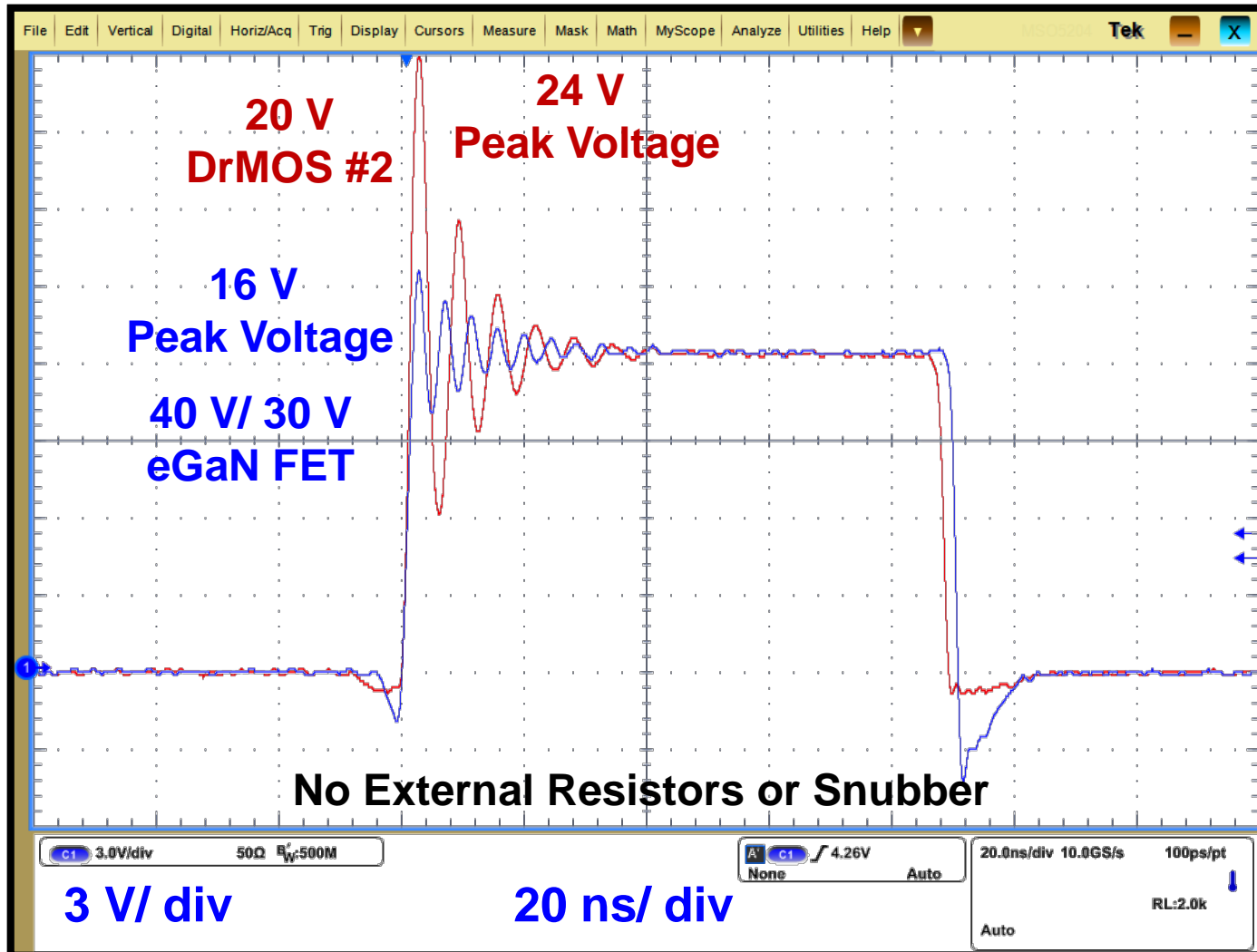


<https://www.fairchildsemi.com/collateral/Generation-II-XS-DrMOS-Family.pdf>

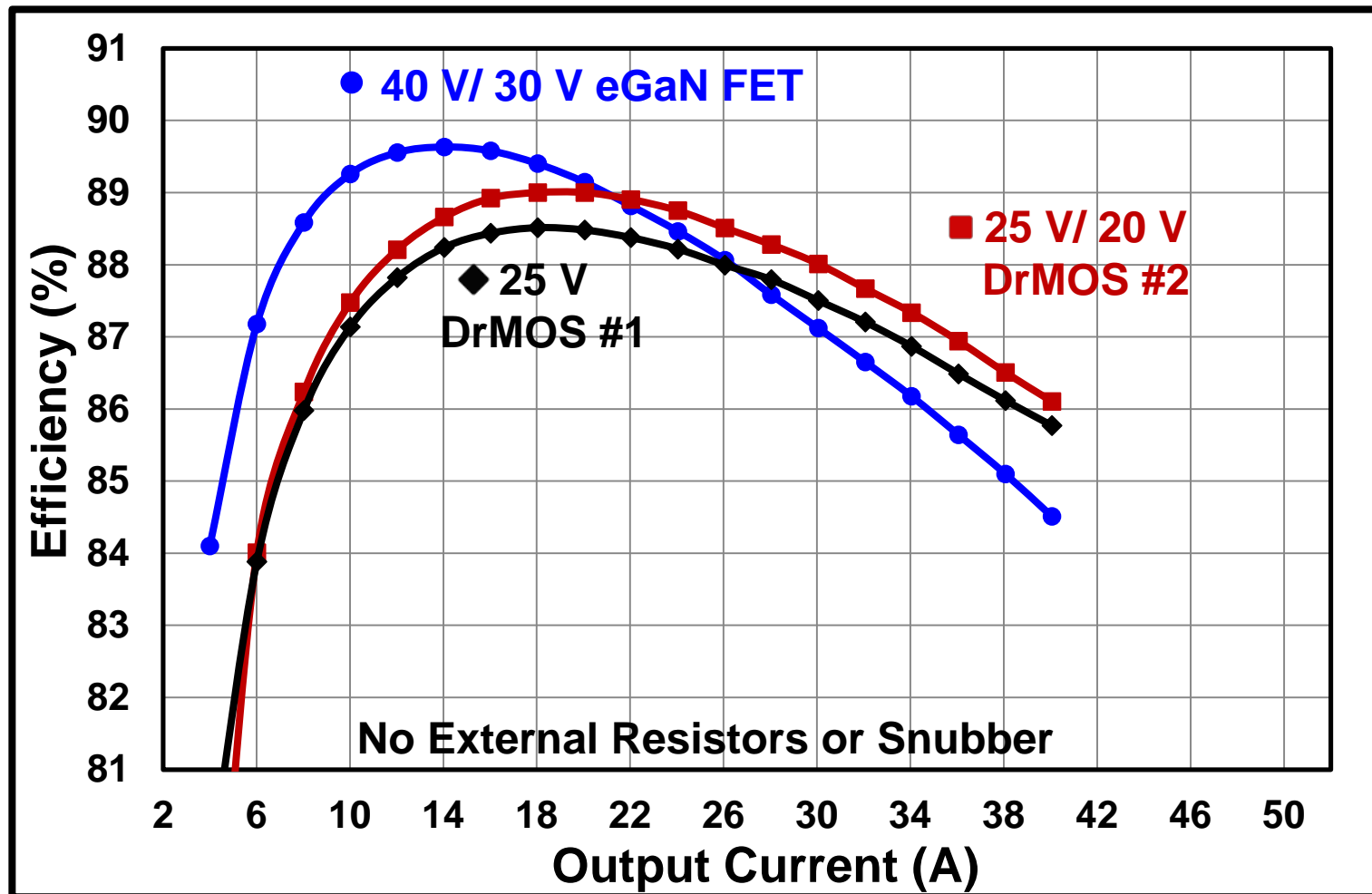
3D packaging advancements drive performance, power and density in power devices
<http://www.ti.com/lit/an/slit126/slit126.pdf>



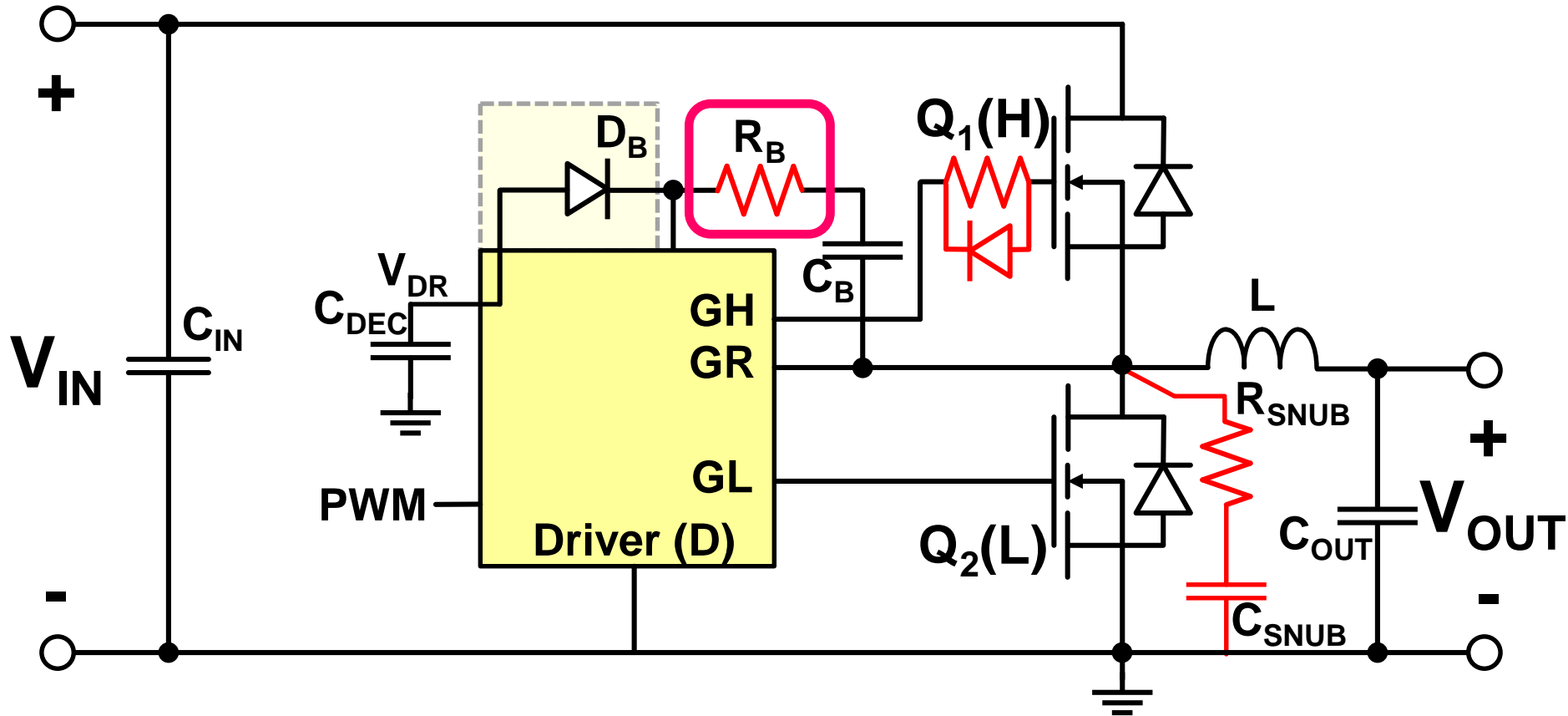
$V_{IN}=12\text{ V}$ $V_{OUT}=1\text{ V}$ $I_{OUT}=20\text{ A}$ $f_{sw}=1\text{ MHz}$ $L=250\text{ nH}$

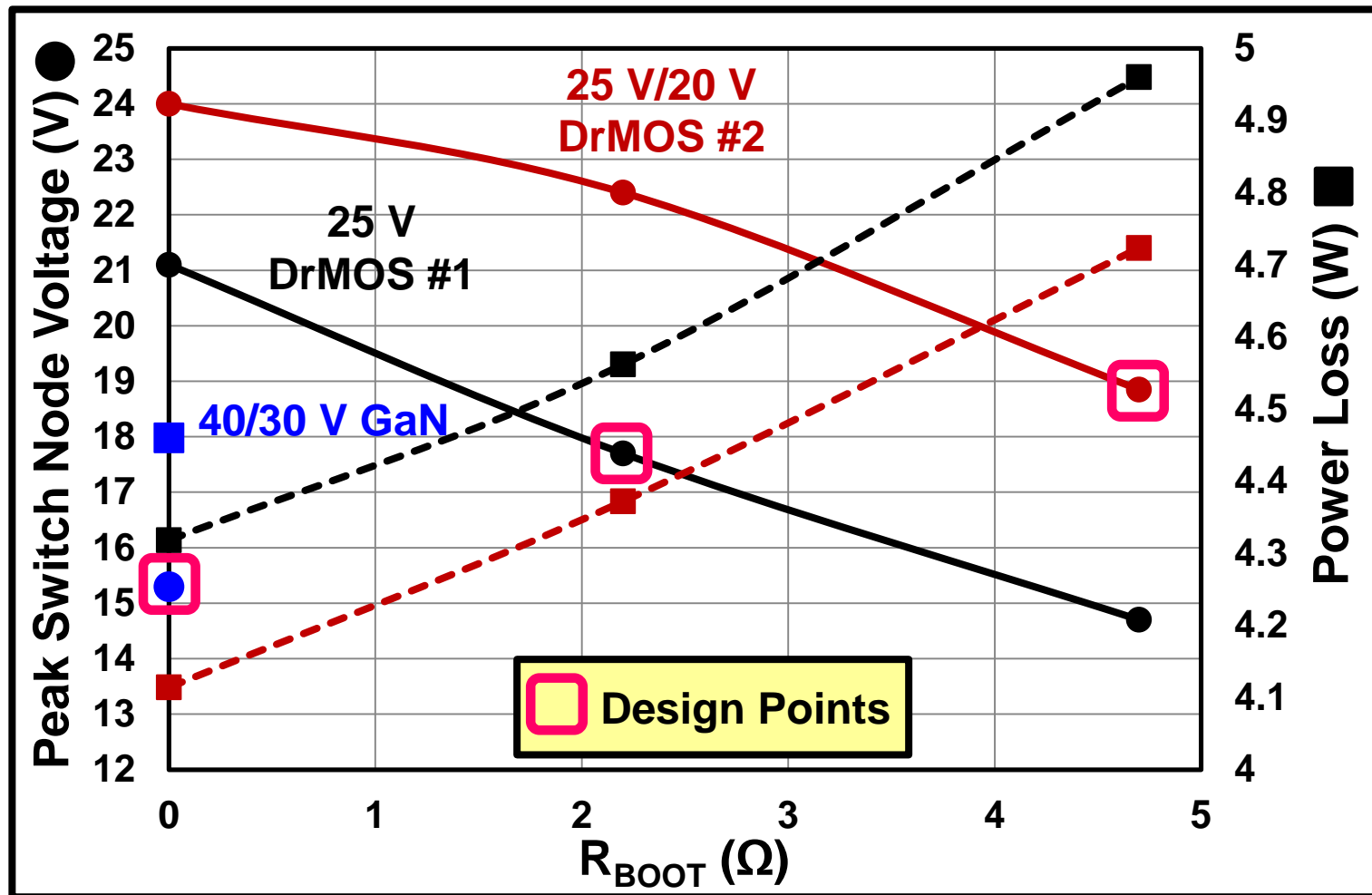


$V_{IN}=12\text{ V}$ $V_{OUT}=1\text{ V}$ $I_{OUT}=20\text{ A}$ $f_{sw}=1\text{ MHz}$ $L=250\text{ nH}$

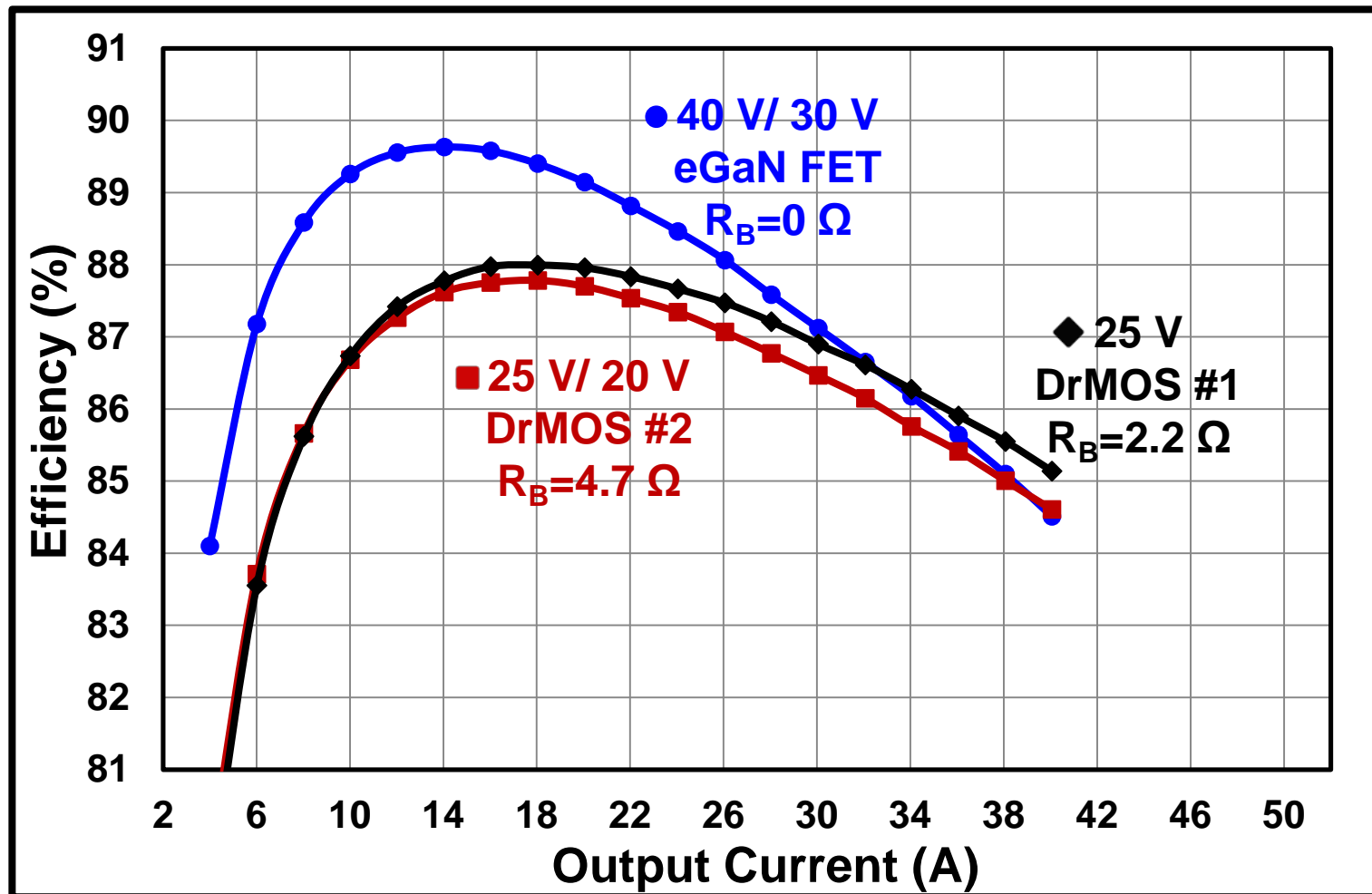


$V_{IN}=12\text{ V}$ $V_{OUT}=1\text{ V}$ $f_{sw}=1\text{ MHz}$ $L=250\text{ nH}$

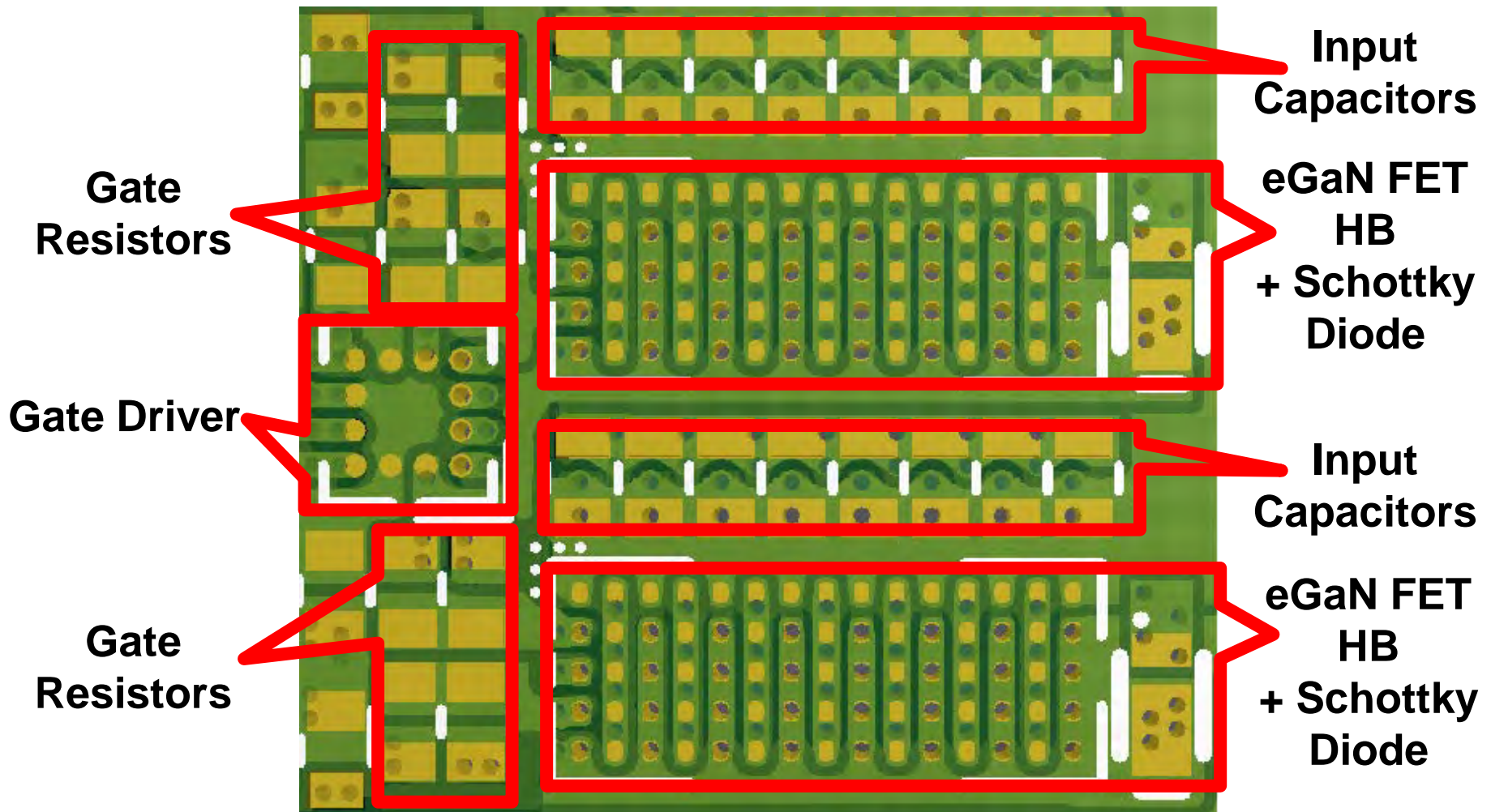


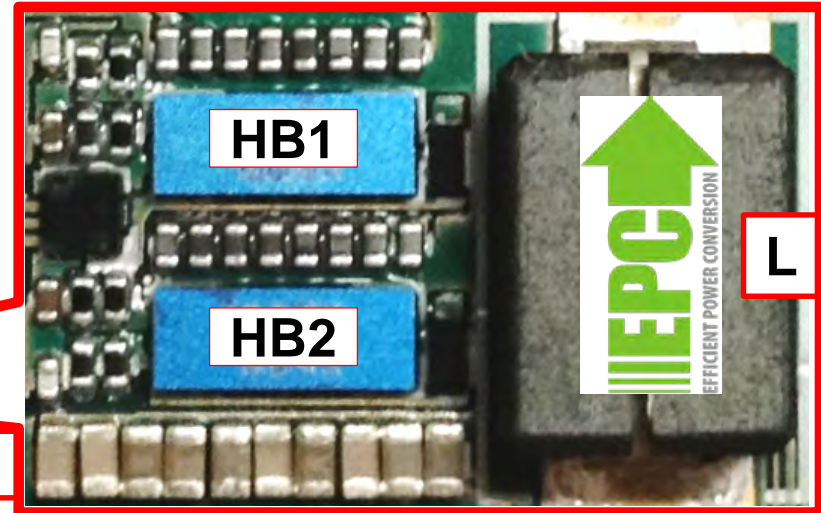


$V_{IN}=12\text{ V}$ $V_{OUT}=1\text{ V}$ $f_{sw}=1\text{ MHz}$ $I_{OUT}=30\text{ A}$ $L=250\text{ nH}$



$V_{IN}=12 \text{ V}$ $V_{OUT}=1 \text{ V}$ $f_{sw}=1 \text{ MHz}$ $L=250 \text{ nH}$



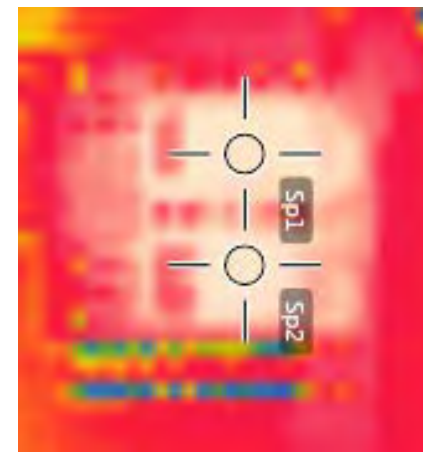


HB1 \approx 103°C

HB2 \approx 101°C

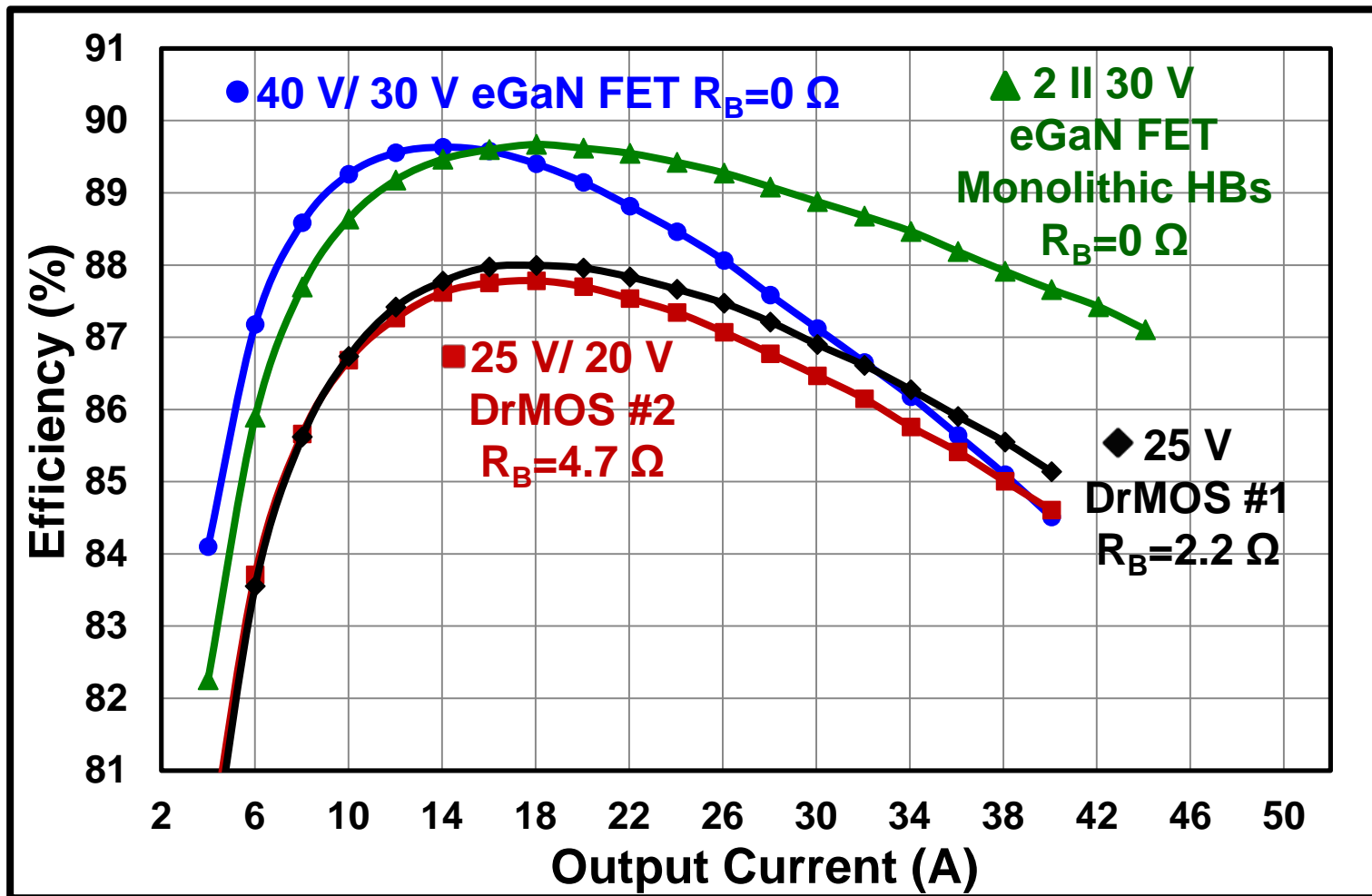
100°C

25°C

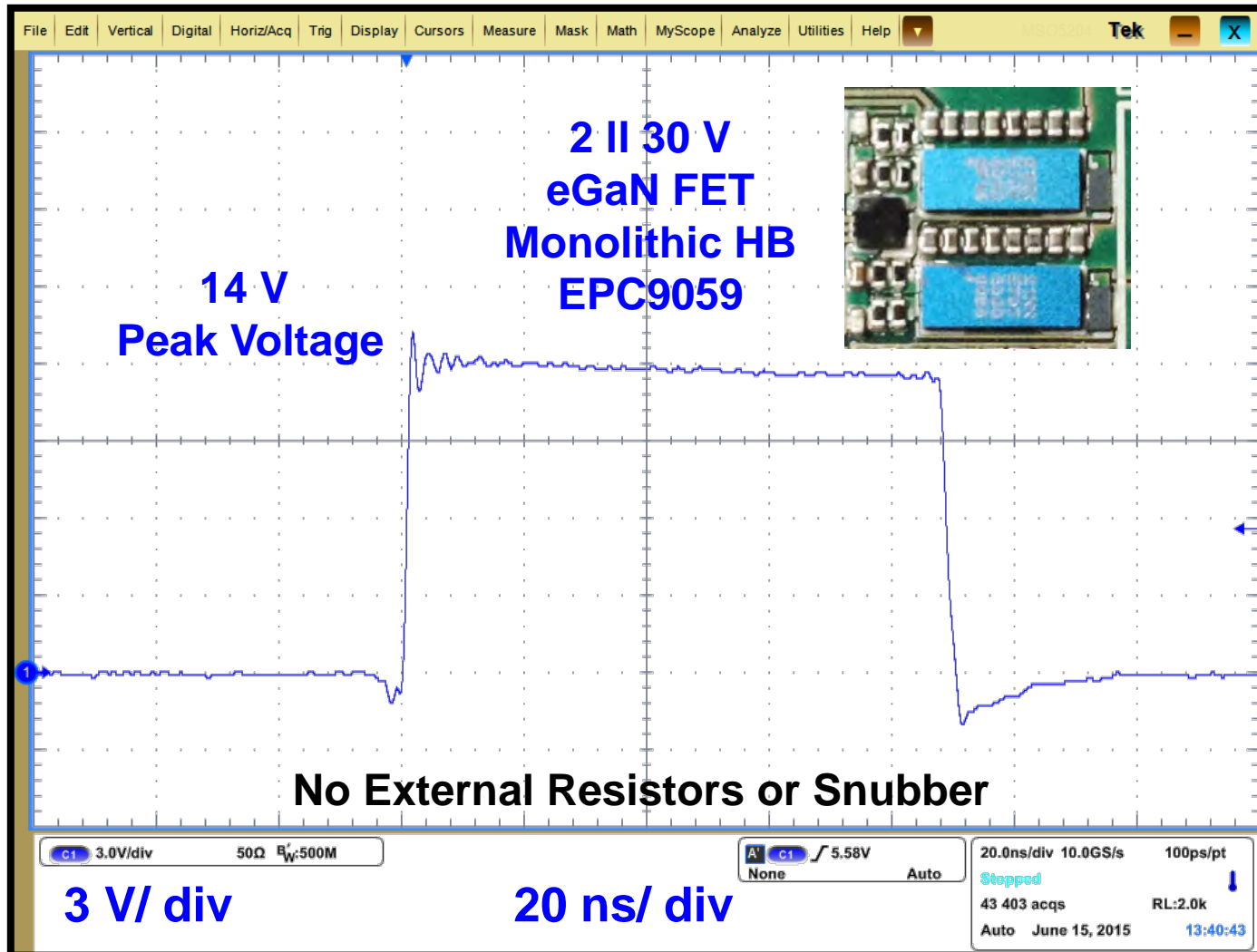


Natural Convection

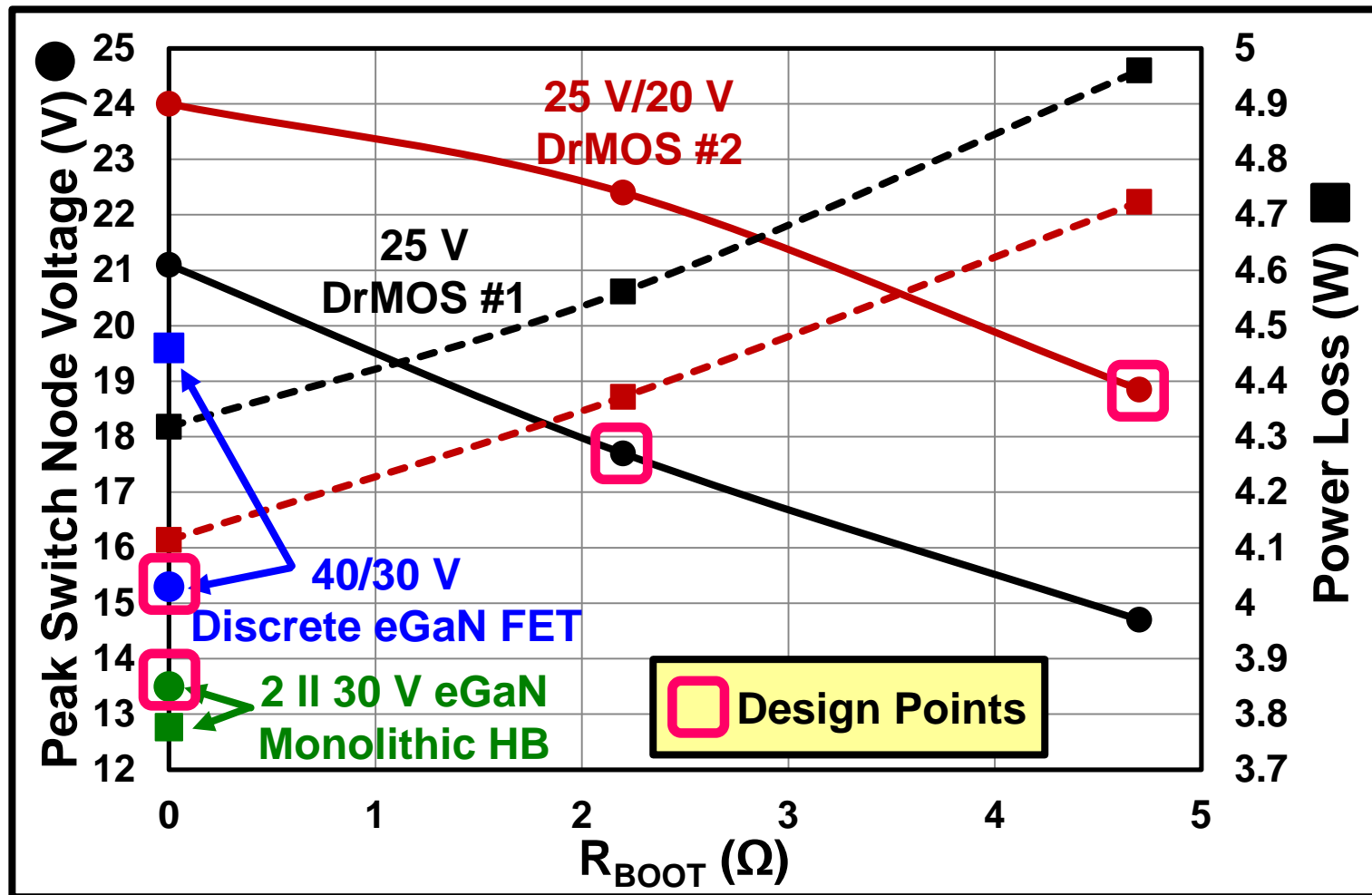
$V_{IN}=12\text{ V}$ $V_{OUT}=1\text{ V}$ $f_{sw}=1\text{ MHz}$ $I_{OUT}=32\text{ A}$



$V_{IN}=12 \text{ V}$ $V_{OUT}=1 \text{ V}$ $f_{sw}=1 \text{ MHz}$ $L=250 \text{ nH}$



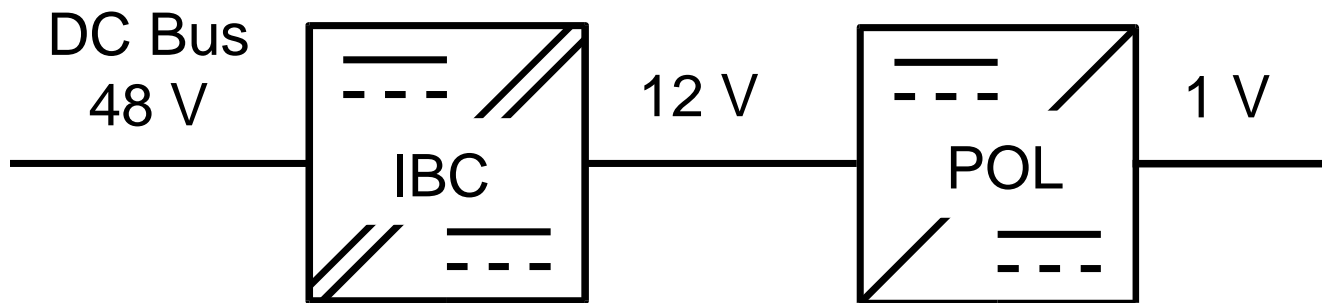
$V_{IN}=12\text{ V}$ $V_{OUT}=1\text{ V}$ $I_{OUT}=20\text{ A}$ $f_{sw}=1\text{ MHz}$ $L=250\text{ nH}$



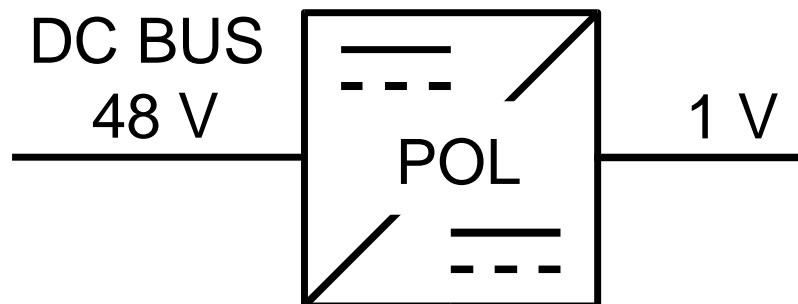
$V_{IN}=12\text{ V}$ $V_{OUT}=1\text{ V}$ $f_{sw}=1\text{ MHz}$ $I_{OUT}=30\text{ A}$ $L=250\text{ nH}$

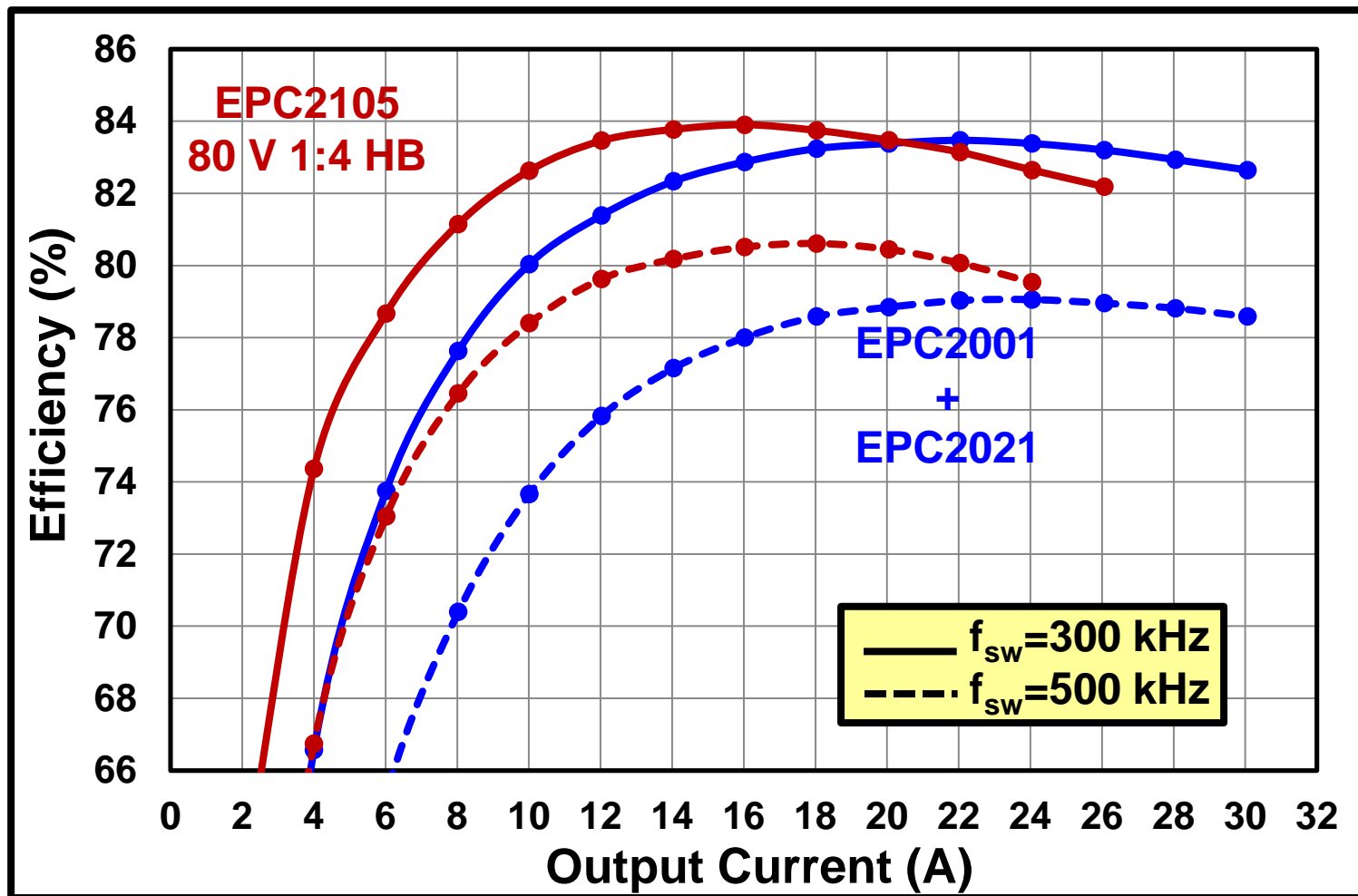
48 V_{IN} to 1 V_{OUT} POL Converter

Intermediate Bus Architecture



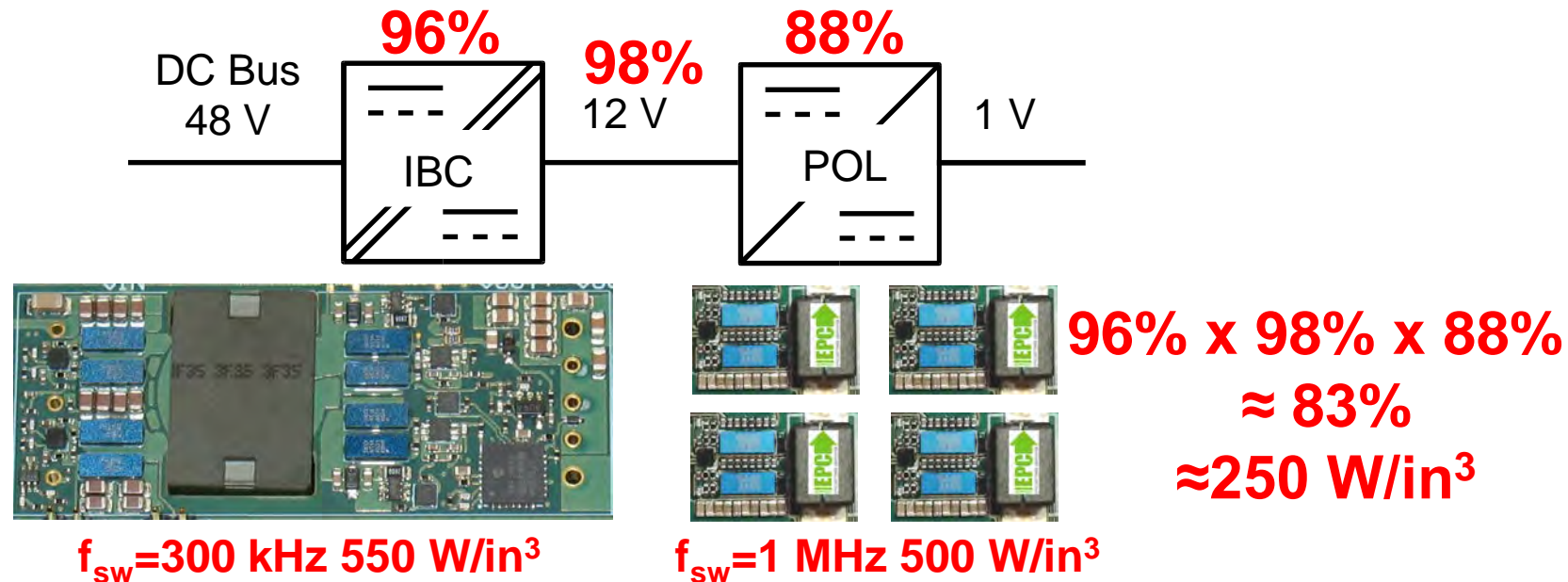
DC Bus Architecture



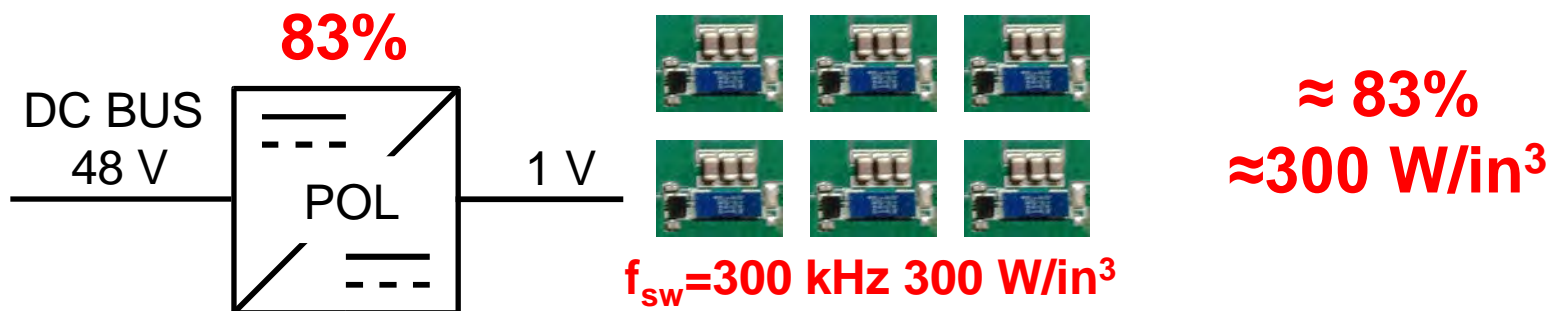


$V_{IN}=48$ V $V_{OUT}=1$ V $L=330$ nH

Intermediate Bus Architecture

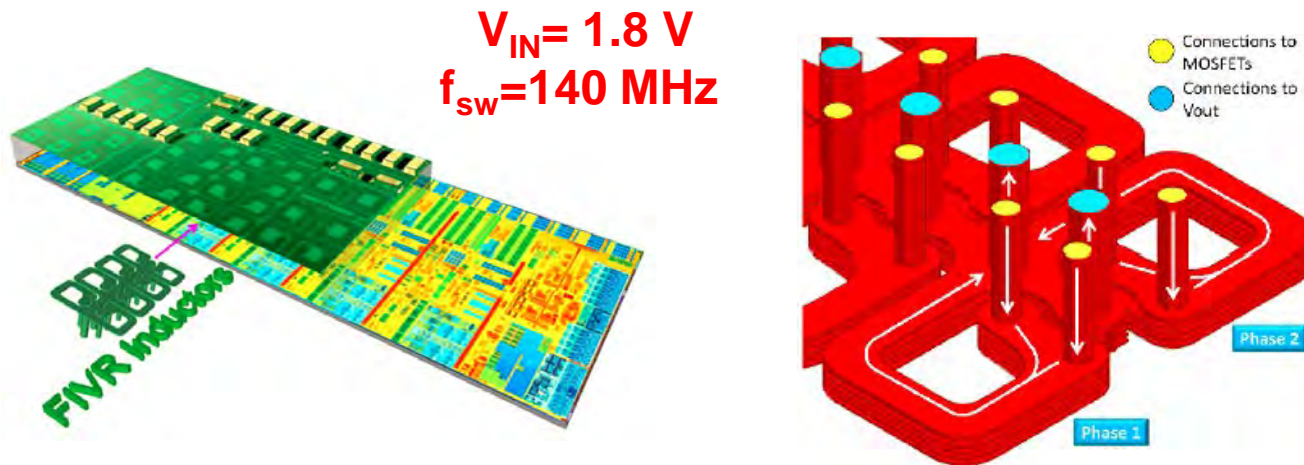


DC Bus Architecture

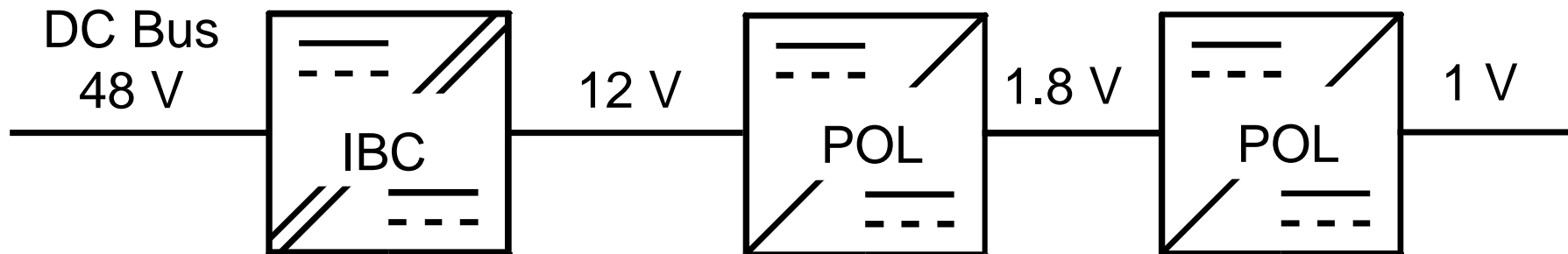


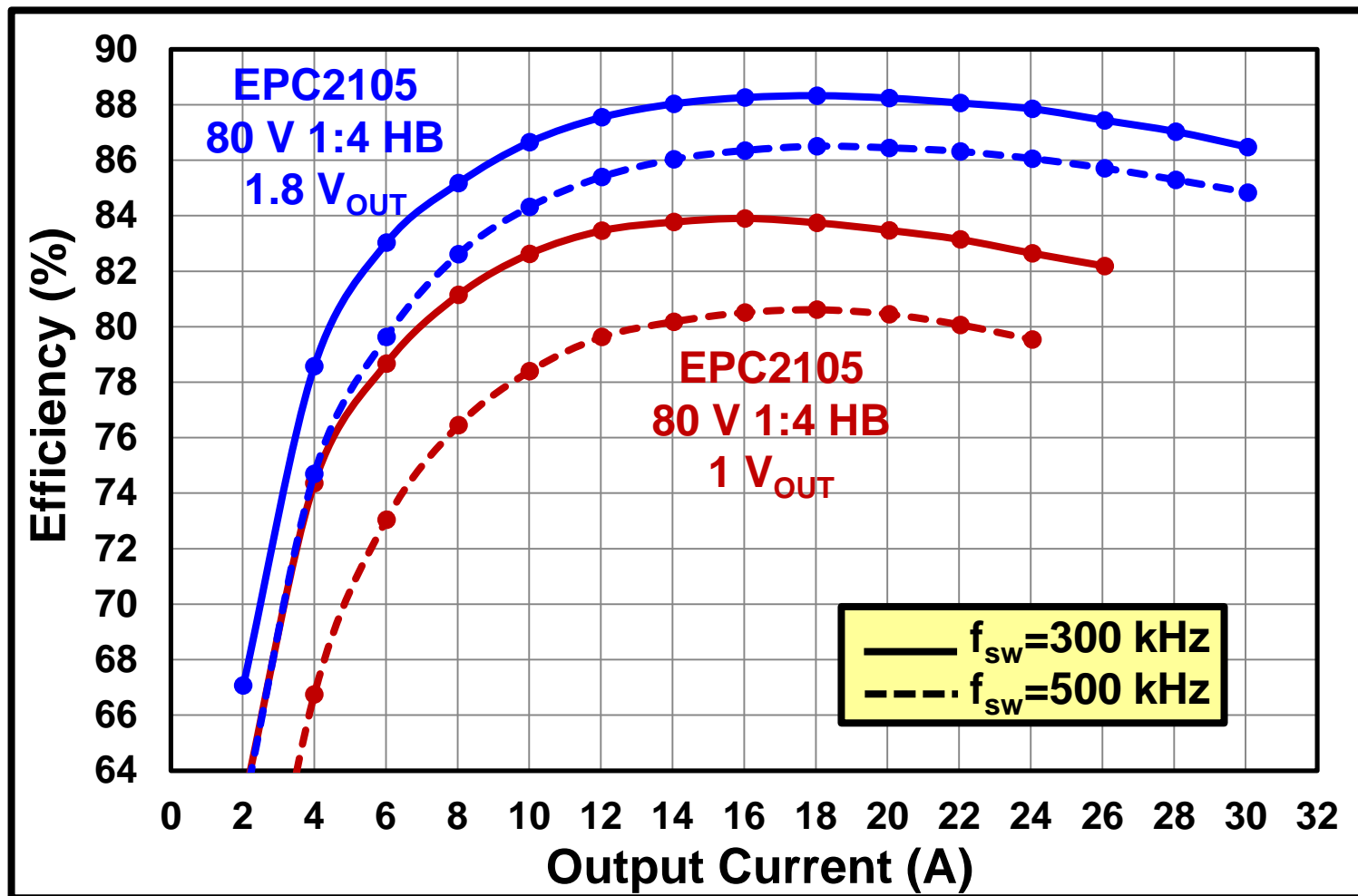
48 V_{IN} to 1.8 V_{OUT} Bus Converter

“FIVR – Fully Integrated Voltage Regulators on 4th Generation Intel® Core™ SoCs” APEC2014



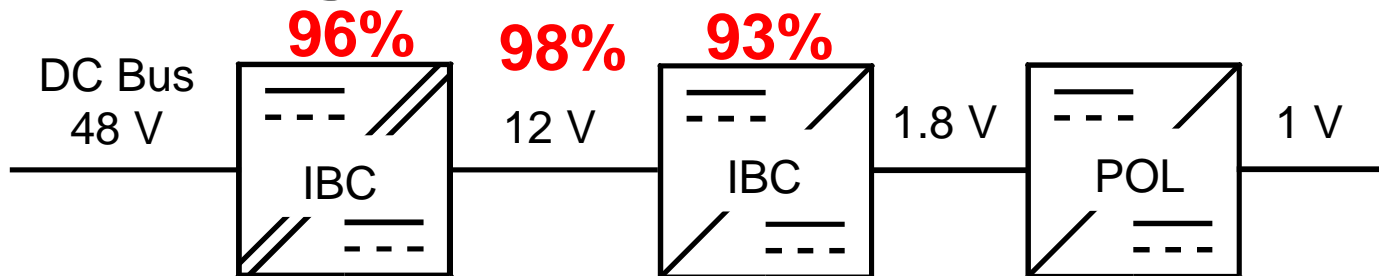
Three Stage Intermediate Bus Architecture



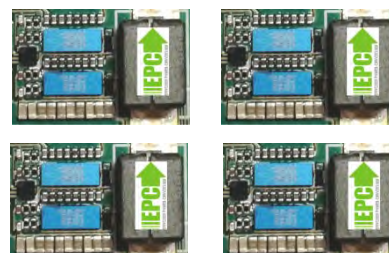


V_{IN}=48 V V_{OUT}=1 V L@ 1V_{OUT}=330 nH V L@1.8 V_{OUT}=470 nH

Three Stage Intermediate Bus Architecture



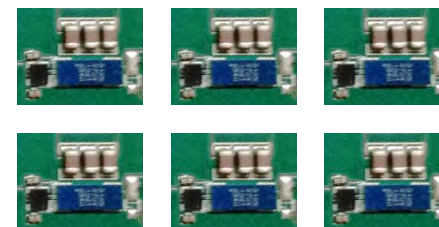
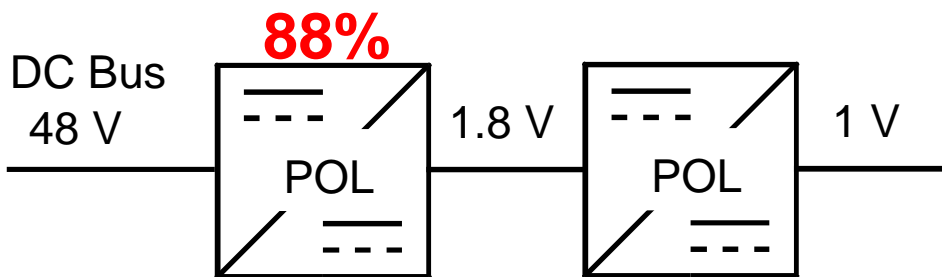
$f_{sw}=300 \text{ kHz } 550 \text{ W/in}^3$



$f_{sw}=1 \text{ MHz } 700 \text{ W/in}^3$

$96\% \times 98\% \times 93\%$
 $\approx 88\%$
 $\approx 300 \text{ W/in}^3$

Two Stage Non-Isolated Intermediate Bus Architecture



$f_{sw}=300 \text{ kHz } 500 \text{ W/in}^3$

$\approx 88\%$
 $\approx 500 \text{ W/in}^3$

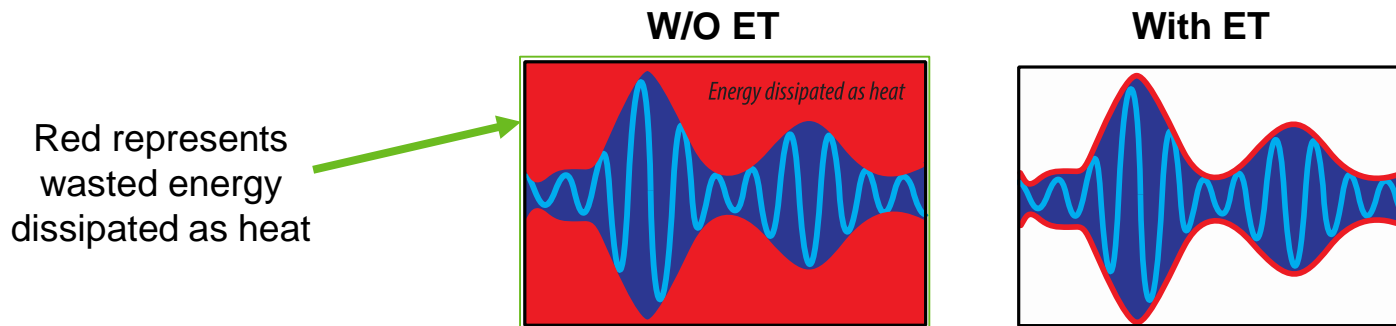
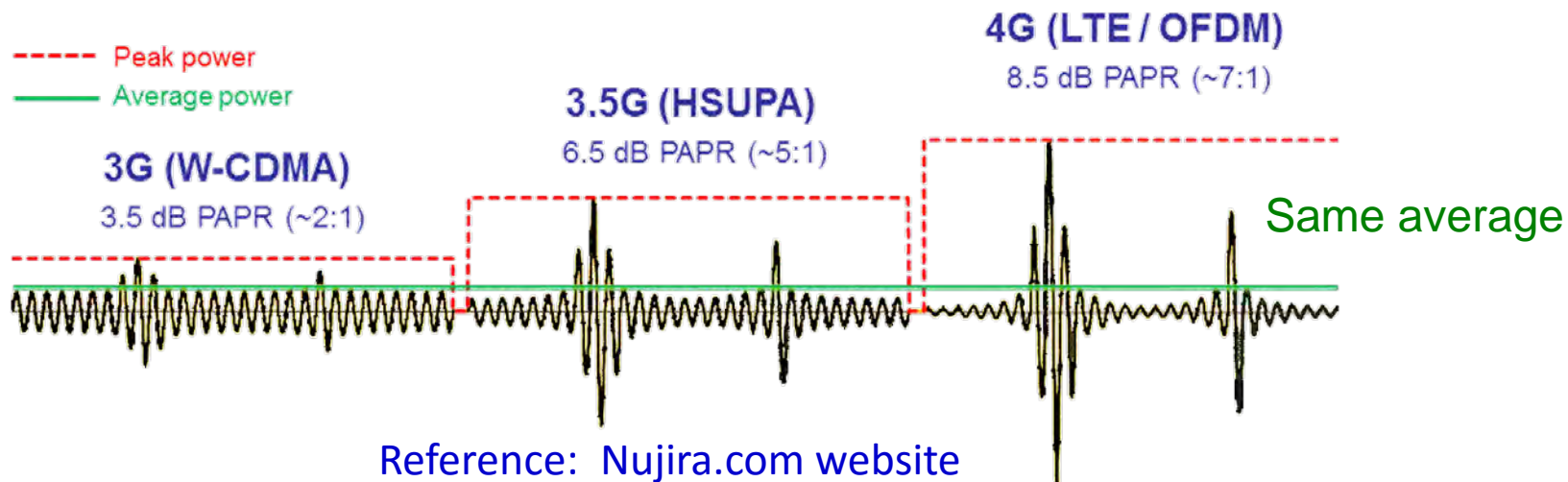
Parameter	Units	48 V _{IN} IBA		48 V _{IN} Direct Conversion
		48 V _{IN} – 12 V _{OUT} IBC	12 V _{IN} – 1.8 V _{OUT} IBC	48 V _{IN} – 1.8 V _{OUT} IBC
Stage Switching Frequency	kHz	300	1000	300
Total Power Devices ^a		22 ^b		18 ^b
System Transformer Isolation		Yes		No
PCB Complexity		High	Low	Low
Stage Efficiency	%	96	93	88
Bus Efficiency	%	98 ^c		99.9%
Total System Efficiency	%	87.5		87.9
Stage Power Density	W/in ³ (W/cm ³)	550 (34)	700 (43)	500 (31)
Total System Power Density	W/in ³ (W/cm ³)	300 (18)		500 (31)
Total System Cost		High		Low

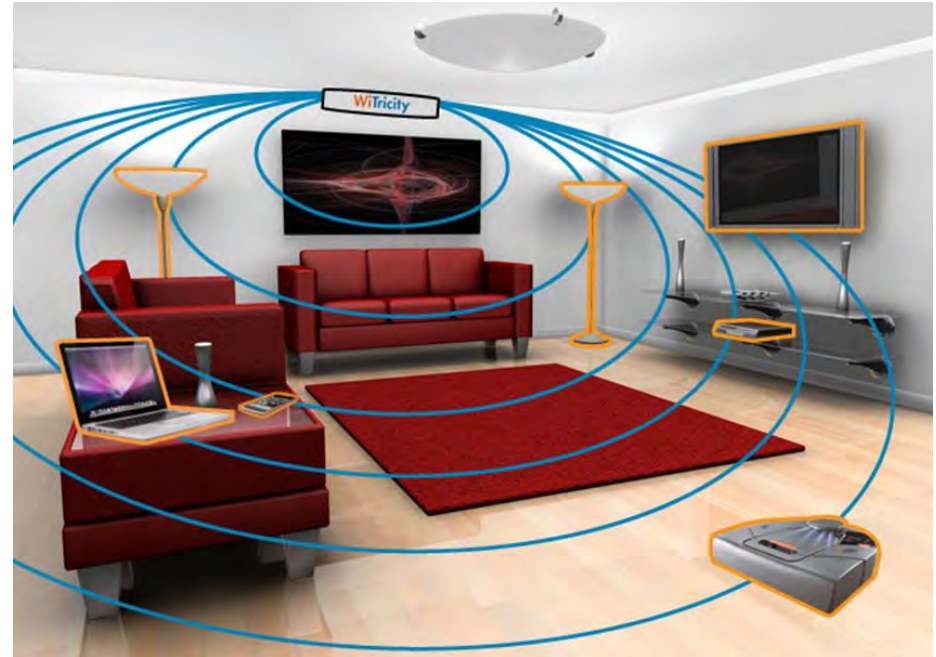
- Initial comparison of Intermediate Bus Architecture and non-isolated DC Bus Architecture for Integrated VR
 - Cost of non-isolated converter will be **much** lower
 - Redundant $12 V_{IN}$ can be removed
 - Efficiency is similar, power density can be higher
 - Transient no longer a concern
- Potential improvements
 - $48 V_{IN}$ to $1.8 V_{OUT}$ isolated bus converter may provide higher efficiency

A Look into the Future

- Does it enable significant new capabilities?
- Is it easy to use?
- Is it VERY cost effective to the user?
- Is it reliable?

- Does it enable significant new capabilities?
- Is it easy to use?
- Is it VERY cost effective to the user?
- Is it reliable?







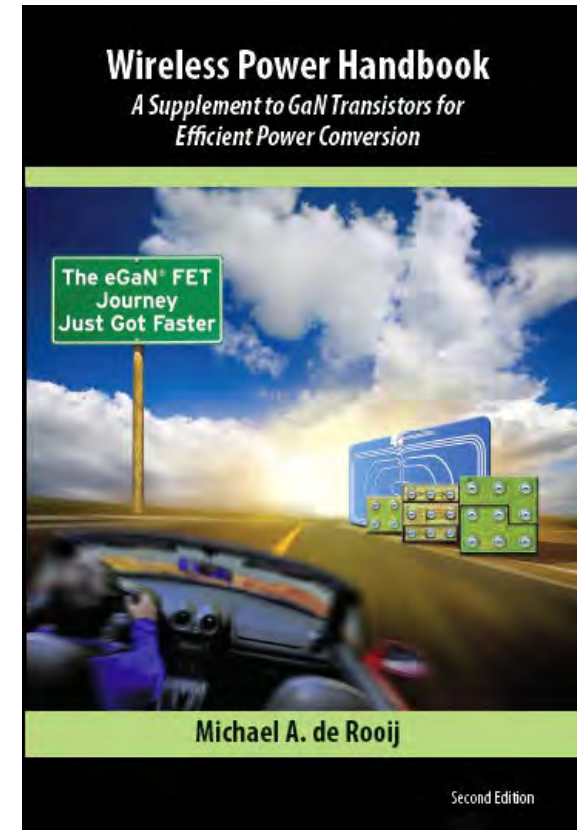
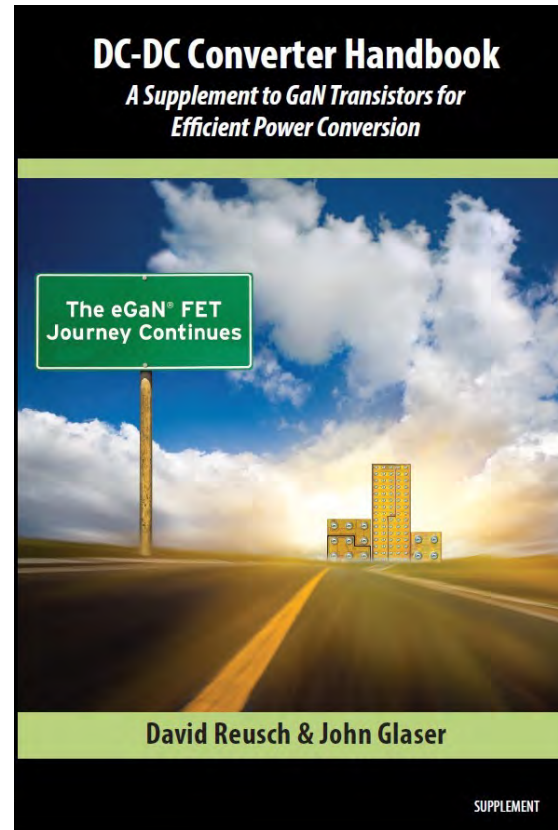
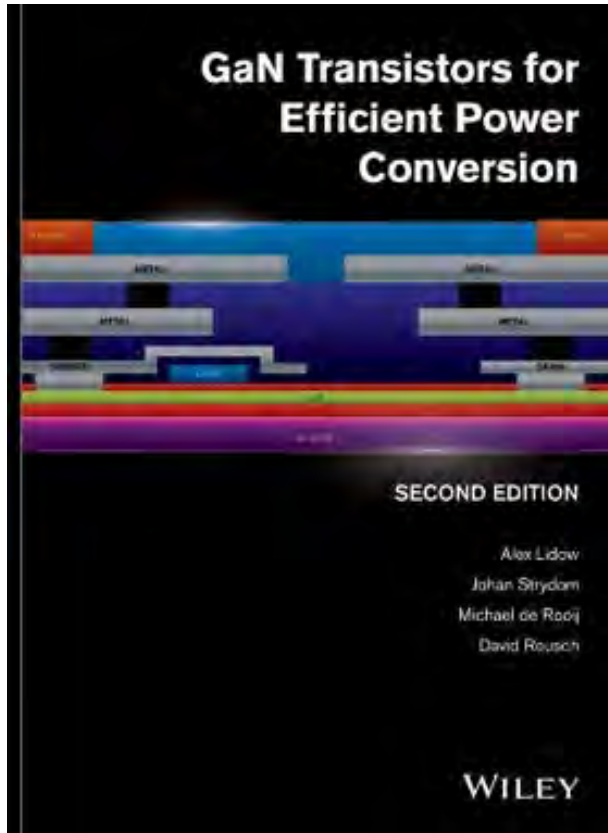
- RadHard
- Energy Efficient Lighting
- Class D Audio
- Various Medical

- Does it enable significant new capabilities?
- **Is it easy to use?**
- Is it VERY cost effective to the user?
- Is it reliable?

It's just like a MOSFET

except

The high frequency capability makes circuits using eGaN FETs sensitive to layout

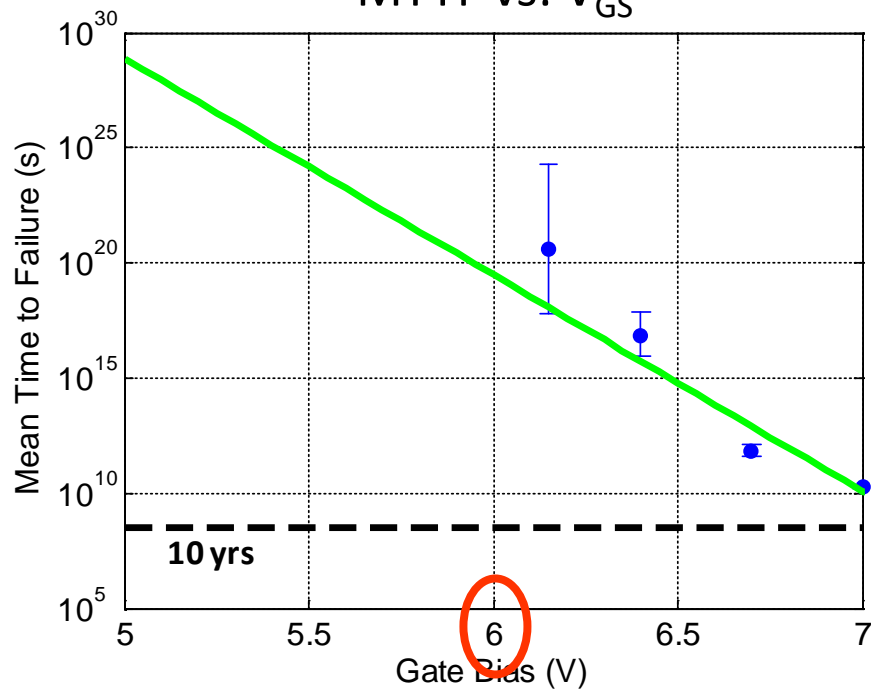


Universities all over the world are graduating well-trained engineers experienced in the use of GaN Transistors

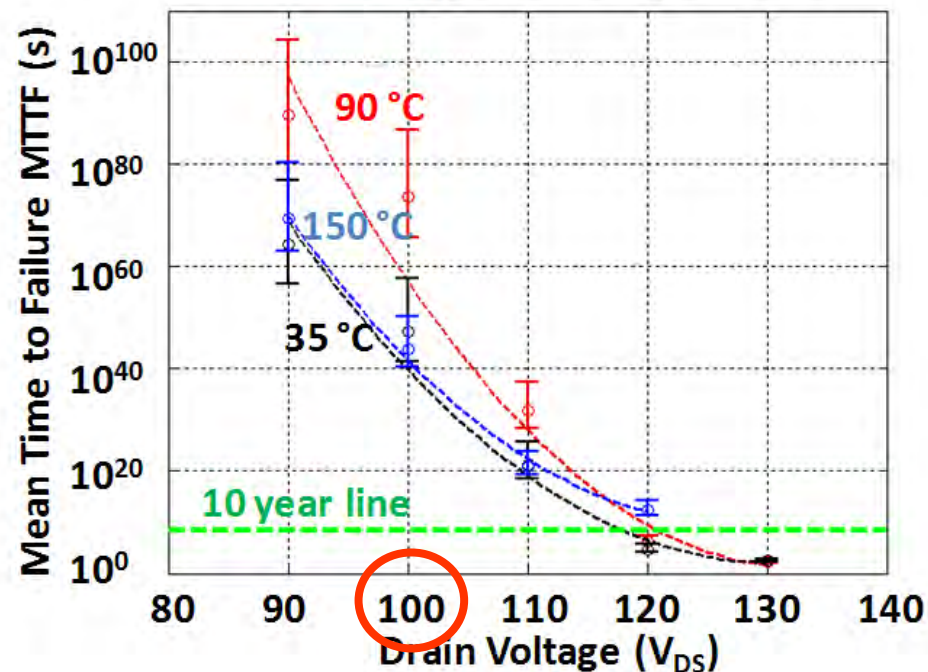
- Virginia Tech
- MIT
- Auburn University
- National Chiao Tung University
- Zhejiang University
- Kyusu Institute of Technology
- University of Tennessee
- University of Illinois
- University of Southern Denmark
- University of Texas
- North Carolina State University
- University of Valencia
- Universität Kassel
- Case Western University
- Colorado State University
- University of Sheffield
- Delft University of Technology
- National Tsing Hua University
- Yamaguchi University
- FH Joanneum - University of Applied Sciences
- University of Cambridge
- Rensselaer Polytechnic Institute
- ETH Zurich
- University of Michigan
- Nanyang Technological University
- Hong Kong University
- Aalborg University
- University of Toronto
- Universidad Miguel Hernandez
- Mid Sweden University
- RFSS Lab
- New Mexico State University
- Seoul Technical University
- Clausthal University of Technology
- Università Di Padova
- University of Johannesburg
- University of North Carolina - Charlotte
- Oregon Tech
- DEEEA-ETSE URV
- University of Maryland
- University of Stuttgart
- The Hong Kong University of Science & Technology
- Tallinn University of Technology
- Harvard University
- University of Toledo
- University of Akron
- University of Dayton
- University of Zaragoza
- Stanford University
- University of Applied Sciences
- University of Bologna
- Missouri University
- University of Wisconsin
- Yale University
- Reutlingen University
- Kyushu University
- Ecomas
- Universidad de Oviedo
- University of Arkansas
- Chiba University
- Shimane University
- University of Florida
- University of Bristol
- Universität Erlangen
- Seoul National University
- University of Hamburg - Institute of Experimental Physics
- Otto-Von-Guerick University
- City University of Hong Kong
- National Central University
- Missouri University of Science and Technology
- DTU Elektro
- Florida State University
- University of North Carolina
- University of Auckland
- Universidad Politecnica de Madrid
- UCLA
- Università di Roma la Sapienza
- Purdue University
- Oita University
- Arizona State University
- University of South Carolina
- University of Utah
- Catholic University of Leuven
- LAPLACE
- Pontifical Xavierian University
- Macquarie University
- Austrian Institute of Technology GmbH
- Auckland University of Technology
- Friedrich-Alexander University
- University of Warwick
- Centro De Estudios E Investigaciones
- Supelec
- University of Nottingham
- Universität Rovira i Virgili
- University of Waikato
- University of Bremen
- Ferdinand-Braun-Institut
- The Ohio State University
- Bloomsburg University
- Queens University
- Pennsylvania State University
- University of Central Florida
- University of Nevada
- University of Manchester
- NTB Hochschule Fur Technik
- University of Hong Kong
- Iowa State University
- Newcastle University
- Imperial College
- Faculte Des Sciences
- Braunschweig University of Technology
- Center for Advanced Power Systems
- University of New South Wales
- Flensburg University of Applied Sciences
- ASIC Lab
- Universite Lille
- Xian JiaoTong Electric
- Queensland University of Technology
- Institute of Technology Sligo
- Dresden University of Technology
- Concordia University ECE
- Korea University
- National University of Colombia
- Universitat Politecnica de Catalunya - EETAC
- Dalhousie University
- Xi'An Jiaotong University
- Federal University of Santa Catarina
- University of Hannover
- Nikhef Institute
- University of Connecticut
- Brunel University
- UC Santa Barbara
- Oregon State University
- University of Applied Sciences Rosenheim
- Instituto de Telecomunicacoes
- Lausitz University
- SUPSI-TTHF Lab
- Naval Postgraduate School
- Texas Tech University
- Curtin University
- Pukyong National University
- Soongsil University
- Space Flight Lab - UTIAS
- National Taiwan University
- University of Pittsburgh
- University of Colorado
- University of Cassino
- Ruhr University Bochum
- University of Zagreb
- Technische Universitaet Berlin
- Integrated System Research Lab
- Denmark Technical University
- University of Washington
- Embry-Riddle Aeronautical University
- Georgia Tech
- Mississippi State University
- Hogeschool van Amsterdam - University of Applied Sciences
- Oregon Institute of Technology
- LS Simulation - Imtek
- University of Applied Sciences Ravensburg-Weingarten
- University of Oulu
- Beijing Jiaotong University
- University of Applied Science Austria
- Sun Yat-Sen University
- Hongik University
- Nagasaki University
- Dartmouth College
- Hochschule Kempten - University of Applied Sciences
- Singapore University of Technology and Design
- Université Laval
- University of Parma
- University of Iowa
- Harbin Industry University
- Rochester Institute of Technology
- Texas A&M University
- Fraunhofer
- University of Applied Sciences Kiel
- Kookmin University
- University of Alberta
- University of Applied Sciences Deggendorf
- University of Windsor
- Carleton University
- College de Maisonneuve
- Chalmers University of Technology
- Wright State University
- Universitat Freiburg
- King's College London
- Rowland Institute at Harvard
- Cardiff University
- Universität Konstanz
- Cornell University

- Does it enable significant new capabilities?
- Is it easy to use?
- Is it VERY cost effective to the user?
- **Is it reliable?**

MTTF vs. V_{GS}

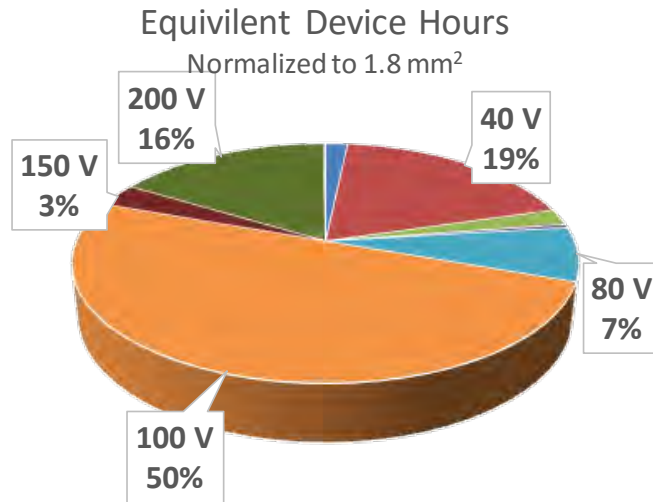


MTTF vs. V_{DS} and Temperature



Alex Lidow and Rob Strittmatter, "Enhancement Mode Gallium Nitride Transistor Reliability", IEEE First International Conference On DC Microgrids (ICDCM) 2015

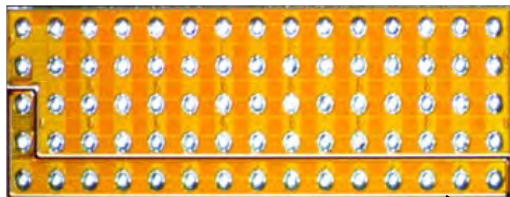
Data as of Oct, 2015



35B equivalent device hours in the field
15B total device hours

- 127 Field Returns (39 Good, 88 Failed)
 - 23 Layout Related
 - 62 Assembly Related
 - 1 Physical Abuse
 - 3 Device degradation (addressed in Gen 4 and screening)
- **3 Device Failures in 15B Hours equals 0.2 FIT**

Gen 3 & 4 FETs and ICs
2014
30 V - 450 V
3 GHz



Higher Power
RF FETs and ICs
Broadband to 6 GHz

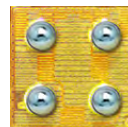


Higher Scale Integrated Circuits



Generation 5
Lower R x A

MOSFET killers



- **GaN is rapidly improving**
- **GaN is not a drop in replacement**
- **GaN transistors will replace silicon power MOSFETs with a lower-cost and higher-efficiency solution.**

Thank You For Your Time ! Questions?